# MEMS Module <br> Application Library Manual 

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## Stationary Analysis of a Biased Resonator-2D

## Introduction

Silicon micromechanical resonators have long been used for designing sensors and are now becoming increasingly important as oscillators in the consumer electronics market. In this sequence of models, a surface micromachined MEMS resonator, designed as part of a micromechanical filter, is analyzed in detail. The resonator is based on that developed in Ref. 1.

This model performs a stationary analysis of the resonator, with an applied DC bias. It is used as a basis for all the subsequent analyses.

## Model Definition

Ref. 1 describes a polysilicon resonator, which is manufactured through a surface micromachining process. The details of this process are outlined in the Stationary Analysis of a Biased Resonator-3D documentation. For this 2D study, a simplified version of the 3D geometry is considered. For simplicity, the resonator is modeled as a $2 \mu \mathrm{~m}$ thick rectangular beam with a length of $45 \mu \mathrm{~m}$. A Fixed Constraint boundary is applied to each end of the resonator to act as the anchor points at which the resonator is attached to the substrate wafer. The wafer substrate is not explicitly modeled, instead only a $0.1985 \mu \mathrm{~m}$ thick air gap between the resonator and the substrate is included. The effects of the driving electrode are included using Electric Potential boundary conditions applied directly to the underside of the air gap, as shown in Figure 1.

Note that although the structure has a plane of symmetry, which vertically bisects the device, we do not use a symmetry boundary condition. A subsequent model considers the normal modes of the structure, and a symmetry condition eliminates the anti-symmetric modes from this analysis.


Figure 1: The model geometry. The rectangular resonator and the air gap are highlighted in red and green outline, respectively. The boundaries to which the driving voltage is applied are
highlighted in blue. Note that the vertical dividing lines are not part of the physical geometry of the resonator, but are included to allow a suitable swept mesh to be easily created.

In operation the bottom surface of the silicon resonator is grounded and a driving electrode applies an electric potential to the central portion of the air gap, as shown in Figure 1 . Typically a DC bias of 35 V is applied in normal operation of the device. In this model the deformation of the structure is computed with the applied DC bias.

## ELECTROMECHANICAL FORCES

Within a vacuum or other medium, forces between charged bodies can be computed on the assumption that a fictitious state of stress exists within the field. The Electromagnetic or Maxwell stress tensor can be used to compute the induced stresses in a material as a result of an electric field as well as surface forces acting on bodies in air or vacuum. Within a material, COMSOL Multiphysics uses the following form of the stress tensor $T_{\mathrm{EM}, S}$, which is appropriate for isotropic materials (Ref. 2):

$$
T_{E M, S}=-\frac{1}{2}\left(\mathbf{E} \cdot \mathbf{D}+a_{2} \mathbf{E} \cdot \mathbf{E}\right) I+\mathbf{E} \mathbf{D}^{T}+\frac{1}{2}\left(a_{2}-a_{1}\right) \mathbf{E} \mathbf{E}^{T}
$$

where $\mathbf{E}$ is the electric field, $\mathbf{D}$ is the electric displacement field, $I$ is the identity tensor, and $\varepsilon_{0}$ is the permittivity of free space and $a_{1}$ and $a_{2}$ are material parameters that specify the electrostrictive properties of the material (for this device, assume $a_{1}=a_{2}=0$ because the field is in any case very low within the material). This additional stress is applied to the material by the electromechanical solid node. Note that mechanical stresses are usually induced in the material as a result of the net forces acting on the surfaces, in addition to the stress induced by the electric field.

The forces on the surfaces of a solid body can be computed by applying a similar stress term within the vacuum of the form:

$$
T_{\mathrm{EM}, V}=-\frac{1}{2}(\mathbf{E} \cdot \mathbf{D}) I+\mathbf{E D}^{T}
$$

A net force on the surface typically results from the discontinuity of the stress tensor at the interface. However, since it is undesirable to apply a stress term throughout the vacuum, the force is only available on the surface of solid bodies, via the electromechanical interface node. The surface force is given by:

$$
\mathbf{n}_{1} T_{\mathrm{EM}, V}=-\left(\frac{1}{2} \mathbf{E} \cdot \mathbf{D}\right) \mathbf{n}_{1}+\left(\mathbf{n}_{1} \cdot \mathbf{E}\right) \mathbf{D}
$$

where $\mathbf{n}_{1}$ is the surface normal, pointing out from the mechanical body.

## Results and Discussion

Figure 2 shows the $y$ displacement of the structure with an applied DC bias. As expected the structural displacement is maximal at the center of the geometry. The maximum displacement is 11.2 nm .

The electric potential contours are shown in Figure 3. The fringing fields extend approximately $1 \mu \mathrm{~m}$ into the gap either side of the driving electrode. Note that the fringing fields are not well resolved due to the structure of the swept mesh. In order to investigate these fields the mesh must be refined on either side of the electrode. Also note that the surface of the resonator is assumed to be perfectly grounded. This is a result of the potential boundary condition used and is equivalent to the assumption that the silicon is a perfect conductor. Although the author's of Ref. 1 do not explicitly give the doping in the polysilicon, it is likely that this assumption is relatively poor given the estimated depletion region width of approximately $0.7 \mu \mathrm{~m}$ that is quoted. This model could be extended to include the effects of semiconductor transport and an improvement on this assumption could be made by adding the electric currents which are induced inside the resonator.


Figure 2: The $y$-displacement of the resonator as a function of position. The maximum displacement occurs in the center of the resonator, immediately over the biasing electrode.


Figure 3: Electric potential contours in the gap between the grounded resonator and the biased driving electrode.

## References

1. F.D. Bannon III, J.R. Clark, and C.T.-C. Nguyen, "High-Q HF

Microelectromechanical Filters," IEEE Journal of Solid State Circuits, vol. 35, no. 4, pp. 512-526, 2000.
2. J.A. Stratton, Electromagnetic Theory, McGraw-Hill, New York, 1941.

Application Library path: MEMS_Module/Actuators/biased_resonator_2d_basic

## Modeling Instructions

From the File menu, choose New.

## N E W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D.
2 In the Select Physics tree, select Structural Mechanics>Electromechanics (emi).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Stationary.
6 Click Done.

GEOMETRY I
I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Rectangle I (rl)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 22.5.
4 In the Height text field, type 2.

5 Locate the Position section. In the $\mathbf{x}$ text field, type -22.5.
6 In the $y$ text field, type 0.1985.
Rectangle 2 (r2)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 22.5.
4 In the Height text field, type 0.1985.
5 Locate the Position section. In the $\mathbf{x}$ text field, type -22.5.

## Rectangle 3 (r3)

I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 10.
4 In the Height text field, type 2.1985.
5 Locate the Position section. In the $\mathbf{x}$ text field, type -10 .
Mirror I (mirl)
I On the Geometry toolbar, click Transforms and choose Mirror.
2 Click the Select Box button on the Graphics toolbar.
3 Click in the Graphics window and then press Ctrl+A to select all objects.
4 In the Settings window for Mirror, locate the Input section.
5 Select the Keep input objects check box.
6 Click Build All Objects.
7 Click the Zoom Extents button on the Graphics toolbar.
Add materials to the model.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select MEMS $>$ Semiconductors $>$ Si - Polycrystalline Silicon.
4 Click Add to Component in the window toolbar.

## ADD MATERIAL

I Go to the Add Material window.

2 In the tree, select Built-In>Air.
3 Click Add to Component in the window toolbar.

## MATERIALS

## Air (mat2)

I In the Model Builder window, under Component I (compl)>Materials click Air (mat2).
2 Select Domains 1, 3, 5, and 7 only.
Set the air material property to be non-solid, to ensure the interface solves the electrostatic equation in the spatial frame.

3 In the Settings window for Material, click to expand the Material properties section.
4 Locate the Material Properties section. From the Material type list, choose Nonsolid.
5 On the Home toolbar, click Add Material to close the Add Material window.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| Vdc | $35[\mathrm{~V}]$ | 35 V | DC bias voltage |

Set up the solid mechanics and electrostatics boundary conditions.
Add a Linear Elastic Material feature to the resonator.

## ELECTROMECHANICS (EMI)

## Linear Elastic Material I

I In the Model Builder window, under Component I (compl) right-click Electromechanics (emi) and choose Linear Elastic Material.

2 Select Domains 2, 4, 6, and 8 only.
Apply a Fixed Constraint to both ends of the resonator.

## Fixed Constraint I

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Structural>Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.

## 3 Click Paste Selection.

4 In the Paste Selection dialog box, type 322 in the Selection text field.
5 Click OK.
Apply the Ground condition to the bottom edge of the resonator.

## Ground I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Ground.
2 In the Settings window for Ground, locate the Boundary Selection section.

## 3 Click Paste Selection.

4 In the Paste Selection dialog box, type 491419 in the Selection text field.
5 Click OK.
Set the bias voltage on the driving electrode with the Electric Potential feature.

## Electric Potential I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Electric Potential.

2 In the Settings window for Electric Potential, locate the Boundary Selection section.

## 3 Click Paste Selection.

4 In the Paste Selection dialog box, type 712 in the Selection text field.
5 Click OK.
6 In the Settings window for Electric Potential, locate the Electric Potential section.
7 In the $V_{0}$ text field, type Vdc.
Modify the default mesh settings to suit the model geometry.
A mapped mesh allows good resolution of the small air gap between the driving electrode and the resonator.

## MESH I

## Distribution I

I In the Model Builder window, under Component I (compl) right-click Mesh I and choose Mapped.

2 Right-click Mapped I and choose Distribution.
3 In the Settings window for Distribution, locate the Boundary Selection section.

## 4 Click Paste Selection.

5 In the Paste Selection dialog box, type 5101520 in the Selection text field.
6 Click OK.
7 In the Settings window for Distribution, locate the Distribution section.
8 In the Number of elements text field, type 15.

## Distribution 2

I Right-click Mapped I and choose Distribution.
2 In the Settings window for Distribution, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 13 in the Selection text field.
5 Click OK.
6 In the Settings window for Distribution, locate the Distribution section.
7 In the Number of elements text field, type 10.
8 Click Build AII.
9 Click the Zoom Extents button on the Graphics toolbar.

## STUDY I

I In the Model Builder window, right-click Study I and choose Rename.
2 In the Rename Study dialog box, type Stationary in the New label text field.
3 Click OK.
4 On the Home toolbar, click Compute.

## RESULTS

Displacement (emi)
I In the Model Builder window, under Results right-click Displacement (emi) and choose Rename.

2 In the Rename 2D Plot Group dialog box, type Biased Displacement in the New label text field.

3 Click OK.

## Surface I

I In the Model Builder window, expand the Results>Biased Displacement node, then click Surface I.

2 In the Settings window for Surface, locate the Expression section.

3 In the Expression text field, type v.

## Biased Displacement

I In the Model Builder window, under Results click Biased Displacement.
2 On the Biased Displacement toolbar, click Plot.
3 Click the Zoom Extents button on the Graphics toolbar.
Compare the resulting plot with that in .
Create a plot to show the electric potential contours in the gap.

## Contour I

I On the Home toolbar, click Add Plot Group and choose 2D Plot Group.
2 In the Model Builder window, right-click 2D Plot Group 3 and choose Contour.
3 In the Settings window for Contour, locate the Levels section.
4 In the Total levels text field, type 10.
2D Plot Group 3
Compare the resulting plot with that in .
I In the Model Builder window, under Results click 2D Plot Group 3.
2 On the 2D Plot Group 3 toolbar, click Plot.
3 Right-click Results>2D Plot Group 3 and choose Rename.
4 In the Rename 2D Plot Group dialog box, type Electric Potential in the New label text field.

5 Click OK.

## Frequency Response of a Biased Resonator-2D

## Introduction

Silicon micromechanical resonators have long been used for designing sensors and are now becoming increasingly important as oscillators in the consumer electronics market. In this sequence of models, a surface micromachined MEMS resonator, designed as part of a micromechanical filter, is analyzed in detail. The resonator is based on that developed in Ref. 1.

This model performs a frequency-domain analysis of the structure, which is also biased with its operating DC offset. The analysis begins from the stationary analysis performed in the accompanying model Stationary Analysis of a Biased Resonator-2D; please review this model first.

## Model Definition

The geometry, fabrication, and operation of the device are discussed for the Stationary Analysis of a Biased Resonator-2D model.

For the frequency-domain analysis of the structure, consider an applied drive voltage consisting of a 35 V DC offset with a 100 mV drive signal added as a harmonic perturbation. Solve the linearized problem to compute the response of the system.

## D A MPING

To obtain the response of the system, you need to add damping to the model. For this study, assume that the damping mechanism is Rayleigh damping or material damping.

To specify the damping, two material constants are required ( $\alpha_{d M}$ and $\beta_{d K}$ ). For a system with a single degree of freedom (a mass-spring-damper system) the equation of motion with viscous damping is given by

$$
m \frac{d^{2} u}{d t^{2}}+c \frac{d u}{d t}+k u=f(t)
$$

where $c$ is the damping coefficient, $m$ is the mass, $k$ is the spring constant, $u$ is the displacement, $t$ is the time, and $f(t)$ is a driving force.

In the Rayleigh damping model, the parameter $c$ is related to the mass, $m$, and the stiffness, $k$, by the equation:

$$
c=\alpha_{d M} m+\beta_{d K} k
$$

The Rayleigh damping term in COMSOL Multiphysics is proportional to the mass and stiffness matrices and is added to the static weak term.

The damping coefficient, $c$, is frequently defined as a damping ratio or factor, expressed as a fraction of the critical damping, $c_{0}$, for the system such that

$$
\xi=\frac{c}{c_{0}}
$$

where for a system with one degree of freedom

$$
c_{0}=2 \sqrt{k m}
$$

Finally note that for large values of the quality factor, $Q$,

$$
\xi \cong \frac{1}{2 Q}
$$

The material parameters $\alpha_{d M}$ and $\beta_{d K}$ are usually not available in the literature. Often the damping ratio is available, typically expressed as a percentage of the critical damping. It is possible to transform damping factors to Rayleigh damping parameters. The damping factor, $\xi$, for a specified pair of Rayleigh parameters, $\alpha_{d M}$ and $\beta_{d K}$, at the frequency, $f$, is

$$
\xi=\frac{1}{2}\left(\frac{\alpha_{d M}}{2 \pi f}+\beta_{d K} 2 \pi f\right)
$$

Using this relationship at two frequencies, $f_{1}$ and $f_{2}$, with different damping factors, $\xi_{1}$ and $\xi_{2}$, results in an equation system that can be solved for $\alpha_{d M}$ and $\beta_{d K}$ :

$$
\left[\begin{array}{l}
\frac{1}{4 \pi f_{1}} \pi f_{1} \\
\frac{1}{4 \pi f_{2}}
\end{array}\right]\left[\begin{array}{l}
\alpha_{d M} \\
\beta_{d K}
\end{array}\right]=\left[\begin{array}{l}
\xi_{1} \\
\xi_{2}
\end{array}\right]
$$

The damping factors for this model are provided as $\alpha_{d M}=4189 \mathrm{~Hz}$ and $\beta_{d K}=8.29 \cdot 10^{-}$ 13 s , consistent with the observed Quality factor of 8000 for the fundamental mode.

## Results and Discussion

Figure 1 shows the frequency response of the resonator. A clear anti-resonance structure for the frequency response is observable. This response can be compared to that shown in Figure 15 (a) in Ref. 1. Although the experimental results are from a pair of coupled
resonators in this instance, the two resonances are sufficiently separate in frequency space that it is possible to distinguish the two modes. If the details of the external circuits were available, a terminal boundary condition with an attached circuit could be used to compute the electrical response of the system for a more direct comparison with the experimental results


Figure 1: Frequency response of the fundamental mode of the resonator.

## Reference

1. F.D. Bannon III, J.R. Clark and C.T.-C. Nguyen, "High-Q HF

Microelectromechanical Filters," IEEE Journal of Solid State Circuits, vol. 35, no. 4, pp. 512-526, 2000.

Application Library path: MEMS_Module/Actuators/biased_resonator_2d_freq

## Modeling Instructions

Open the existing stationary study (filename: biased_resonator_2d_basic.mph).
From the File menu, choose Open.
Browse to the model's Application Libraries folder and double-click the file biased_resonator_2d_basic.mph.

Create parameters for the material damping factors.

## GLOBAL DEFINITIONS

## Parameters

I In the Model Builder window, expand the Global Definitions node, then click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| alpha | $4189[\mathrm{~Hz}]$ | 4189 Hz | Damping parameter - alpha |
| beta | $8.29 \mathrm{e}-13[\mathrm{~s}]$ | $8.29 \mathrm{E}-13 \mathrm{~s}$ | Damping parameter - beta |

COMPONENT I (COMPI)
In the Model Builder window, expand the Component I (compl) node.

## ELECTROMECHANICS (EMI)

Add damping to the physics settings.
Linear Elastic Material I
In the Model Builder window, expand the Component I (compl)>Electromechanics (emi) node.

Damping I
I Right-click Linear Elastic Material I and choose Damping.
2 In the Settings window for Damping, locate the Damping Settings section.
3 In the $\alpha_{\mathrm{d} M}$ text field, type alpha.
4 In the $\beta_{\mathrm{d} K}$ text field, type beta.
Add a Harmonic Perturbation to the DC bias term, to represent the AC drive voltage.

## Harmonic Perturbation I

I In the Model Builder window, under Component I (compl)>Electromechanics (emi) rightclick Electric Potential I and choose Harmonic Perturbation.

2 In the Settings window for Harmonic Perturbation, locate the Electric Potential section.
3 In the $V_{0}$ text field, type 0.1.
Set up the frequency domain study.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Prestressed Analysis, Frequency Domain.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

## Step 2: Frequency-Domain Perturbation

I In the Model Builder window, under Study 2 click Step 2: Frequency-Domain Perturbation.
2 In the Settings window for Frequency-Domain Perturbation, locate the Study Settings section.

3 In the Frequencies text field, type range (7.95[MHz],0.01[MHz], $8.25[\mathrm{MHz}])$.
4 In the Model Builder window, right-click Study 2 and choose Rename.
5 In the Rename Study dialog box, type Frequency domain in the New label text field.
6 Click OK.
7 In the Settings window for Study, locate the Study Settings section.
8 Clear the Generate default plots check box.
9 On the Home toolbar, click Compute.
Produce a plot of the frequency response of the system.

## RESULTS

ID Plot Group 4
I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.

3 From the Data set list, choose Frequency domain/Solution 2 (sol2).
4 Right-click ID Plot Group 4 and choose Rename.
5 In the Rename ID Plot Group dialog box, type Frequency Domain in the New label text field.

6 Click OK.

## Point Graph I

I Right-click Frequency Domain and choose Point Graph.
2 In the Settings window for Point Graph, locate the Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 9 in the Selection text field.
5 Click OK.
6 In the Settings window for Point Graph, locate the y-Axis Data section.
7 In the Expression text field, type $v$.
8 On the Frequency Domain toolbar, click Plot. Compare the resulting plot with .

## Normal Modes of a Biased Resonator-2D

## Introduction

Silicon micromechanical resonators have long been used for designing sensors and are now becoming increasingly important as oscillators in the consumer electronics market. In this sequence of models, a surface micromachined MEMS resonator, designed as part of a micromechanical filter, is analyzed in detail. The resonator is based on that developed in Ref. 1.

This model performs a modal analysis on the resonator, with and without an applied DC bias. The analysis begins from the stationary analysis performed in the accompanying model Stationary Analysis of a Biased Resonator-2D; please review this model first.

## Model Definition

The geometry, fabrication, and operation of the device are discussed for the "Stationary Analysis of a Biased Resonator" model.

This model performs a modal analysis on the structure, with and without applied DC voltage biases of different magnitudes. The bias already exists as a parameter in the model so the prestressed eigenfrequency solver needs no adjustment to the physics settings. To compute the unbiased eigenfrequency, the solver settings are adjusted to solve only the structural mechanics problem.

## Results and Discussion

Figure 1 shows the mode shapes for the resonator under different bias conditions.
The mode shape does not change significantly with applied bias and the first three modes have the expected shapes for a clamped-clamped beam. The frequency of the fundamental is reduced significantly by the applied bias, an effect known as spring softening (the response of higher-order modes was not computed as a function of applied bias).


Figure 1: Mode shapes for the resonator under different bias conditions (top line: 0 V; bottom line: 45 V ). The mode frequencies are indicated in the figure. The colors visualize the relative $y$-displacement magnitude.

The spring softening effect can be seen in detail in Figure 2. A clear decrease in the resonant frequency is evident with increasing bias voltage. This figure should be compared with Figure 16 of Ref. 1, where the same effect is apparent.


Figure 2: Mode frequency shown against the applied DC voltage bias. The spring softening effect is evident. Compare with Fig. 16 of Ref. 1.

## Notes About the COMSOL Implementation

This model excludes certain dependent variables from the solver settings in order to compute the unbiased eigenfrequency. By not computing for the electric potential or the displacement of the air domains, the model is equivalent to a pure solid mechanics problem, solved in the absence of external forces. Excluding dependent variables in the solver in this manner can be useful for debugging models as well as for computing uncoupled problems in this manner.

## Reference

1. F.D. Bannon III, J.R. Clark, and C. T.-C. Nguyen, "High-Q HF

Microelectromechanical Filters", IEEE Journal of Solid State Circuits, vol. 35, no. 4, pp. 512-526, 2000.

Application Library path: MEMS_Module/Actuators/biased_resonator_2d_modes

## Modeling Instructions

Open the existing stationary study (filename: biased_resonator_2d_basic.mph).
From the File menu, choose Open.
Browse to the model's Application Libraries folder and double-click the file biased_resonator_2d_basic.mph.

## ROOT

Add an unbiased eigenfrequency study. The settings for this study need to be modified so that only the structural part of the problem is solved.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Custom Studies> Eigenfrequency.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

Step I: Eigenfrequency
I In the Model Builder window, under Study 2 click Step I: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Study Settings section.
3 Select the Desired number of eigenfrequencies check box.
4 In the associated text field, type 3.
5 In the Model Builder window, right-click Study 2 and choose Rename.
6 In the Rename Study dialog box, type Unbiased Eigenfrequency in the New label text field.
7 Click $\mathbf{O K}$.
Set up the solver to solve only for the solid mechanics variables.

## Solution 2 (sol2)

On the Study toolbar, click Show Default Solver.

## UNBIASED EIGENFREQUENCY

## Solution 2 (sol2)

I In the Model Builder window, expand the Solution 2 (sol2) node, then click Dependent Variables I.

2 In the Settings window for Dependent Variables, locate the General section.
3 From the Defined by study step list, choose User defined.
4 In the Model Builder window, expand the Unbiased Eigenfrequency> Solver Configurations>Solution 2 (sol2)>Dependent Variables I node, then click Electric potential (compl.V).

5 In the Settings window for Field, locate the General section.
6 Clear the Solve for this field check box.
7 Clear the Store in output check box.
8 In the Model Builder window, under Unbiased Eigenfrequency>Solver Configurations> Solution 2 (sol2)>Dependent Variables I click Spatial coordinates (comp I.xy).

9 In the Settings window for Field, locate the General section.
10 Clear the Solve for this field check box.
II Clear the Store in output check box.
I2 In the Model Builder window, click Unbiased Eigenfrequency.
13 In the Settings window for Study, locate the Study Settings section.
14 Clear the Generate default plots check box.
15 On the Study toolbar, click Compute.
Set the data set to be in the material frame for post-processing. This allows the use of the deformation plot attribute.

## RESULTS

## Unbiased Eigenfrequency/Solution 2 (sol2)

I In the Model Builder window, expand the Results>Data Sets node, then click Unbiased Eigenfrequency/Solution 2 (sol2).
2 In the Settings window for Solution, locate the Solution section.

3 From the Frame list, choose Material (X, Y, Z).
Plot the mode shapes.

## 2D Plot Group 4

I On the Home toolbar, click Add Plot Group and choose 2D Plot Group.
2 In the Settings window for 2D Plot Group, locate the Data section.
3 From the Data set list, choose Unbiased Eigenfrequency/Solution 2 (sol2).
4 Right-click 2D Plot Group 4 and choose Rename.
5 In the Rename 2D Plot Group dialog box, type Unbiased Modes in the New label text field.
6 Click OK.
Surface I
I Right-click Unbiased Modes and choose Surface.
2 In the Settings window for Surface, locate the Expression section.
3 In the Expression text field, type v.

## Deformation I

I Right-click Results>Unbiased Modes>Surface I and choose Deformation.
2 On the Unbiased Modes toolbar, click Plot.
3 Click the Zoom Extents button on the Graphics toolbar.
Compare the mode shapes with those shown in for all the modes computed. To switch between the modes click Unbiased Modes and choose a different value from the Eigenfrequency list.

## ROOT

Add a Prestressed Analysis, Eigenfrequency study.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Prestressed Analysis, Eigenfrequency.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 3

Step I: Stationary
I In the Model Builder window, right-click Study 3 and choose Rename.
2 In the Rename Study dialog box, type Biased Eigenfrequency in the New label text field.

3 Click OK.
Create a parametric sweep over DC bias voltage.

## Parametric Sweep

On the Study toolbar, click Parametric Sweep.

## BIASED EIGENFREQUENCY

## Parametric Sweep

I In the Settings window for Parametric Sweep, locate the Study Settings section.
2 Click Add.
3 Click Range.
4 In the Range dialog box, type 5 in the Start text field.
5 In the Step text field, type 5.
6 In the Stop text field, type 45.
7 Click Add.
Solve for only the first eigenfrequency.

## Step 2: Eigenfrequency

I In the Model Builder window, under Biased Eigenfrequency click Step 2: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Study Settings section.
3 Select the Desired number of eigenfrequencies check box.
4 In the associated text field, type 1.
Disable the default plots.
5 In the Model Builder window, click Biased Eigenfrequency.
6 In the Settings window for Study, locate the Study Settings section.
7 Clear the Generate default plots check box.
8 On the Study toolbar, click Compute.

## RESULTS

## Biased Eigenfrequency/Parametric Solutions I (sol5)

I In the Model Builder window, under Results>Data Sets click Biased Eigenfrequency/ Parametric Solutions I (sol5).

2 In the Settings window for Solution, locate the Solution section.
3 From the Frame list, choose Material (X, Y, Z).

## Unbiased Modes I

I In the Model Builder window, under Results right-click Unbiased Modes and choose Duplicate.

2 Right-click Unbiased Modes I and choose Rename.
3 In the Rename 2D Plot Group dialog box, type Biased Modes in the New label text field.
4 Click OK.
5 In the Settings window for 2D Plot Group, locate the Data section.
6 From the Data set list, choose Biased Eigenfrequency/Parametric Solutions I (sol5).
7 On the Biased Modes toolbar, click Plot.
8 Click the Zoom Extents button on the Graphics toolbar.
Confirm the mode shape is similar to the unbiased fundamental mode.
Create a plot of eigenfrequency vs. applied DC voltage.

## ID Plot Group 6

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.
3 From the Data set list, choose Biased Eigenfrequency/Parametric Solutions I (sol5).
4 Right-click ID Plot Group 6 and choose Rename.
5 In the Rename ID Plot Group dialog box, type Eigenfrequency vs DC voltage in the New label text field.

6 Click OK.

## Point Graph I

I Right-click Eigenfrequency vs DC voltage and choose Point Graph.
2 In the Settings window for Point Graph, locate the Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 1 in the Selection text field.
5 Click OK.

6 In the Settings window for Point Graph, locate the $\boldsymbol{y}$-Axis Data section.
7 In the Expression text field, type emi.freq.
8 Locate the x-Axis Data section. From the Axis source data list, choose Outer solutions.
9 Click to expand the Title section. From the Title type list, choose Custom.
10 Find the Type and data subsection. Clear the Type check box.
II Clear the Description check box.
I2 Find the User subsection. In the Prefix text field, type Eigenfrequency vs DC Voltage.
$\mathbf{I 3}$ Click to expand the Coloring and style section. Locate the Coloring and Style section. Find the Line style subsection. From the Line list, choose None.

14 Find the Line markers subsection. From the Marker list, choose Square.
15 From the Positioning list, choose In data points.
Compare this plot with that in. Note the spring softening effect.
16 On the Eigenfrequency vs DC voltage toolbar, click Plot.
17 Click the Zoom Extents button on the Graphics toolbar.

## Pull-In Voltage for a Biased Resonator-2D

## Introduction

Silicon micromechanical resonators have long been used for designing sensors and are now becoming increasingly important as oscillators in the consumer electronics market. In this sequence of models, a surface micromachined MEMS resonator, designed as part of a micromechanical filter, is analyzed in detail. The resonator is based on that developed in Ref. 1.

This model performs a pull-in analysis of the structure, to predict the point at which the biased system becomes unstable. The analysis begins from the stationary analysis performed in the accompanying model Stationary Analysis of a Biased Resonator-2D; please review this model first.

## Model Definition

The geometry, fabrication, and operation of the device are discussed for the "Stationary Analysis of a Biased Resonator" model.

This model computes the pull-in voltage for the resonator by solving an inverse problem. The $y$-coordinate of the resonator midpoint is computed using an integration operator (intop1). The inverse problem that COMSOL solves computes the DC voltage that must be applied to the beam in order to move the midpoint to a set $y$-coordinate, yset. This is achieved by adding a global equation for the DC voltage, VdcSP, applied to the resonator. The equation intop1 ( y ) - yset $=0$ is solved to determine the value of VdcSP. This means that VdcSP is adjusted until the midpoint of the resonator has a $y$-coordinate given by the set value, yset. Essentially COMSOL is being asked to find the voltage that allows the beam to exist in equilibrium (stable or unstable) at a given displacement. Solving the problem in this manner avoids complications with trying to solve a problem with no solution (which is what happens if the voltage is continuously ramped up eventually exceeding the pull-in voltage). The result of the analysis is a displacement versus voltage plot, with a minimum at the pull-in voltage. Note that for a linear spring, the pull-in displacement corresponds to $1 / 3$ of the gap distance. Although the inclusion of geometric nonlinearities in the solid mechanics solver means that the pull-in displacement changes slightly from this value, it is usually most efficient to search around this point for the pullin voltage.

## Results and Discussion

Figure 1 shows the voltage-displacement curve for the resonator at equilibrium, for $y$ coordinates that correspond to displacements of around $1 / 3$ of the gap size. The pull-in voltage is 63.3 V .


Figure 1: Voltage required to achieve a set displacement versus the target displacement. The pull-in voltage is the minimum of the plot: 63.3 V .


Figure 2: $y$-displacement of the resonator at pull-in. The displacement at pull-in is 74 nm . For a linear spring the displacement at pull in would be 66 nm .

Figure 2 shows the $y$-displacement of the resonator at the pull-in voltage. The maximum displacement at pull-in is 74 nm . This is comparable to the (approximate) linear spring value of 66 nm .

## Notes About the COMSOL Implementation

To compute the voltage required to generate the desired displacement of the beam, use a global equation. A common use of global equations is for computing the value of a dependent variable based on an ordinary differential equation in the dependent variable itself. However, it is also possible to couple a global equation with the other PDEs in the model as a powerful tool to solve certain kinds of inverse problems. This model uses a global equation to compute the potential applied to the drive electrode. The equation takes the form

$$
y_{0}=y_{\mathrm{set}}
$$

where $y_{0}$ is the $y$-coordinate of the midpoint of the beam's underside and $y_{\text {set }}$ is the desired $y$-coordinate. COMSOL Multiphysics computes the voltage to satisfy the constraint implied by the above equation.

## Reference

1. F.D. Bannon III, J.R. Clark and C.T.-C. Nguyen, "High-Q HF

Microelectromechanical Filters," IEEE Journal of Solid State Circuits, vol. 35, no. 4, pp. 512-526, 2000.

Application Library path: MEMS_Module/Actuators/
biased_resonator_2d_pull_in

## Modeling Instructions

Open the existing stationary study (filename: biased_resonator_2d_basic.mph).
From the File menu, choose Open.
Browse to the model's Application Libraries folder and double-click the file biased_resonator_2d_basic.mph.

Add a parameter to set the $y$-coordinate of the midpoint of the resonator.

## GLOBAL DEFINITIONS

## Parameters

I In the Model Builder window, expand the Global Definitions node, then click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| yset | $100[\mathrm{~nm}]$ | IE-7 m | Set point y-coordinate |

Add an integration operator to compute the actual displacement.

## DEFINITIONS

## Integration I (intop I)

I On the Definitions toolbar, click Component Couplings and choose Integration.
2 In the Settings window for Integration, locate the Source Selection section.
3 From the Geometric entity level list, choose Point.

## 4 Click Paste Selection.

5 In the Paste Selection dialog box, type 8 in the Selection text field.
6 Click OK.
Change the drive potential to the value VdcSP - which will be solved for in a global equation.

## ELECTROMECHANICS (EMI)

## Electric Potential I

I In the Model Builder window, expand the Component I (compl)>Electromechanics (emi) node, then click Electric Potential I.

2 In the Settings window for Electric Potential, locate the Electric Potential section.
3 In the $V_{0}$ text field, type VdcSP[V].
4 In the Model Builder window's toolbar, click the Show button and select Advanced Physics Options in the menu.
Add a global equation to compute the voltage for a given displacement, VdcSP.

## Global Equations I

I In the Model Builder window, right-click Electromechanics (emi) and choose Global>
Global Equations.
2 In the Settings window for Global Equations, locate the Global Equations section.
3 In the table, enter the following settings:

| Name | f(u,ut,utt,t) (I) | Initial value <br> $\left(\mathbf{u} \_\mathbf{0}\right)(\mathbf{I})$ | Initial value <br> $\left(\mathbf{u} \_\mathbf{t 0}\right)(\mathbf{I} \mathbf{s})$ | Description |
| :--- | :--- | :--- | :--- | :--- |
| VdcSP | (intop1 (y)-yset)/yset | 0 | 0 |  |

Set up a parametric sweep over the displacement set point, yset.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.

3 Find the Studies subsection. In the Select Study tree, select Preset Studies>Stationary.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

## Step I: Stationary

I In the Model Builder window, right-click Study 2 and choose Rename.
2 In the Rename Study dialog box, type Pull In in the New label text field.
3 Click OK.

## PULL IN

## Step I: Stationary

I In the Settings window for Stationary, click to expand the Study extensions section.
2 Locate the Study Extensions section. Select the Auxiliary sweep check box.
3 Click Add.
4 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| yset | range $(115[\mathrm{~nm}], 2[\mathrm{~nm}], 140[\mathrm{~nm}])$ |  |

The problem is highly non-linear due to the presence of the global equation, so the solver settings need to be adjusted accordingly.

## Solution 2 (sol2)

I On the Study toolbar, click Show Default Solver.
2 In the Model Builder window, expand the Solution 2 (sol2) node.
3 In the Model Builder window, expand the Pull In>Solver Configurations>Solution 2 (sol2)> Stationary Solver I node, then click Fully Coupled I.

4 In the Settings window for Fully Coupled, click to expand the Method and termination section.

5 Locate the Method and Termination section. From the Nonlinear method list, choose Automatic highly nonlinear (Newton).

6 On the Study toolbar, click Compute.
Determine the pull-in voltage by plotting VdcSP vs. yset.

## RESULTS

## ID Plot Group 6

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 6 and choose Rename.
3 In the Rename ID Plot Group dialog box, type Pull In Plot in the New label text field.
4 Click OK.

## Global I

I Right-click Pull In Plot and choose Global.
2 In the Settings window for Global, locate the Data section.
3 From the Data set list, choose Pull In/Solution 2 (sol2).
4 Locate the $\mathbf{y}$-Axis Data section. In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| VdcSP | 1 | Voltage required to reach set point |

5 Locate the x-Axis Data section. From the Parameter list, choose Expression.
6 In the Expression text field, type yset.
7 On the Pull In Plot toolbar, click Plot.
8 Click the Zoom Extents button on the Graphics toolbar.
Compare the resulting plot with. The pull in voltage is the minimum of the curve: 63.3 $V$ at $y s e t=125 \mathrm{~nm}$.
Produce a plot of the y displacement of the structure at pull-in.

## Biased Displacement I

I In the Model Builder window, under Results right-click Biased Displacement and choose Duplicate.

2 Right-click Biased Displacement I and choose Rename.
3 In the Rename 2D Plot Group dialog box, type Pull In Displacement in the New label text field.

4 Click OK.
5 In the Settings window for 2D Plot Group, locate the Data section.
6 From the Data set list, choose Pull In/Solution 2 (sol2).
7 From the Parameter value (yset (m)) list, choose I.25E-7.
8 On the Pull In Displacement toolbar, click Plot.

9 Click the Zoom Extents button on the Graphics toolbar.
Compare the resulting plot with .

## Stationary Analysis of a Biased Resonator-3D

## Introduction

Silicon micromechanical resonators have long been used for designing sensors and are now becoming increasingly important as oscillators in the consumer electronics market. This sequence of models analyzes in detail a surface micromachined MEMS resonator, designed as part of a micromechanical filter. The resonator is based on that developed in Ref. 1.

This model performs a stationary analysis of the resonator, with an applied DC bias. It serves as a basis for all the subsequent analyses.

## Model Definition

The model consists of a poly-silicon resonator, which is manufactured through a surface micromachining process. Initially, a silicon wafer is coated with $0.75 \mu \mathrm{~m}$ of oxide and $0.15 \mu \mathrm{~m}$ of silicon nitride to isolate the micromachined parts from the wafer ground plane. Polysilicon electrodes with a thickness of $0.3 \mu \mathrm{~m}$ are deposited next. A sacrificial layer of oxide is then deposited to a thickness of 198.5 nm . Note that in Ref. 1 the sacrificial oxide is actually $1.3 \mu \mathrm{~m}$, but the gap thickness was adjusted to this value for the purposes of simulation to account for the depletion layer in the silicon. This model uses the same adjustment to enable the simulations to be directly compared with those presented in the paper. Holes are etched in the sacrificial layer (to provide anchor points for the resonator) and the structural polysilicon is deposited with a thickness of $1.9 \mu \mathrm{~m}$.

The structure has a plane of symmetry, so it is possible to model only half of the geometry explicitly, although care must be taken to mirror the geometry before performing a modal analysis. Figure 1 shows the geometry.


Figure 1: Top: Device geometry. The wafer itself is not shown explicitly, but is represented in the model by a ground plane on the underside of the geometry. Bottom: The model geometry as it appears in COMSOL.

The layers of deposited material from the ground plane up are: silicon oxide, silicon nitride (too thin to see clearly), polysilicon electrodes/air gap (etched sacrificial oxide), polysilicon resonator, and air.

In operation, both the silicon resonator and the underlying wafer are grounded and an electric voltage is applied to the driving electrode, which is bisected by the symmetry plane.

Typically a DC bias of 35 V is applied in normal operation of the device. The assumption is made that the polysilicon is a perfect conductor, so the bias voltage is applied on all exterior surfaces of the resonator and its anchor as a potential boundary condition. In this model, the deformation of the structure is computed with the applied DC bias. Note that the silicon oxide and nitride are assumed to be rigid for the solid mechanics simulations, so the structure is anchored at the base of its electrode, and these domains are not included in the solid mechanics equations.

## ELECTROMECHANICAL FORCES

Within a vacuum or other medium, forces between charged bodies can be computed on the assumption that a fictitious state of stress exists within the field. The Electromagnetic or Maxwell stress tensor can be used to compute the induced stresses in a material as a result of an electric field as well as surface forces acting on bodies in air or vacuum. In this model, it is assumed that the polysilicon is doped sufficiently heavily that it can be treated as a perfect conductor. The electric field is assumed to be zero inside the resonator, which means that the Maxwell stress tensor is zero inside the material and there are no volumetric electrical forces. The Maxwell stress tensor in the medium surrounding the resonator, where the electric field is non-zero is (Ref. 2)

$$
T_{\mathrm{EM}, V}=-\frac{1}{2}(\mathbf{E} \cdot \mathbf{D}) I+\mathbf{E D}^{T}
$$

A net force on the surface typically results from the discontinuity of the stress tensor at the interface. However, because it is undesirable to apply a stress term throughout the vacuum, the force is only computed on the surface of the resonator, and is applied by the Electromechanical Interface node. The surface force is given by

$$
\mathbf{n}_{1} T_{\mathrm{EM}, V}=-\left(\frac{1}{2} \mathbf{E} \cdot \mathbf{D}\right) \mathbf{n}_{1}+\left(\mathbf{n}_{1} \cdot \mathbf{E}\right) \mathbf{D}
$$

where $\mathbf{n}_{1}$ is the surface normal, pointing out from the mechanical body.

## Results and Discussion

Figure 2 shows the $z$ displacement of the structure with an applied DC bias. As expected the structural displacement is maximal on the symmetry plane at the center of the device. The maximum displacement is 13 nm . Electric potential isosurfaces are also shown in Figure 2. As expected, the isobars are uniformly distributed and closest together between the resonator and the electrode. This corresponds to a region of uniform electric field. Around the electrode the fringing fields can also be seen. Note that the surface of the
resonator is assumed to be perfectly grounded. This is a result of the potential boundary condition used and is equivalent to the assumption that the polysilicon is a perfect conductor.


Figure 2: The $z$-displacement of the resonator as a function of position. The maximum displacement occurs in the center of the resonator, immediately over the biasing electrode. Electric potential isosurfaces with values of 10 V (green), 20 V (yellow), and 30 V (red) are also shown.

## References

l. F.D. Bannon III, J.R. Clark, and C.T.-C. Nguyen, "High-Q HF

Microelectromechanical Filters," IEEE Journal of Solid State Circuits, vol. 35, no. 4, pp. 512-526, 2000.
2. J.A. Stratton, Electromagnetic Theory, McGraw-Hill, New York, 1941.

Application Library path: MEMS_Module/Actuators/biased_resonator_3d_basic

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Electromechanics (emi).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Stationary.

## 6 Click Done.

For convenience, the device geometry is inserted from an existing file. You can read the instructions for creating the geometry in the .

## GEOMETRY I

I On the Geometry toolbar, click Insert Sequence.
2 Browse to the model's Application Libraries folder and double-click the file biased_resonator_3d_geom_sequence.mph.
3 On the Geometry toolbar, click Build All.
Add a parameter for the applied DC bias.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| Vdc | $35[\mathrm{~V}]$ | 35 V | DC bias voltage |

Create selections to facilitate easy set up of the boundary conditions.

## DEFINITIONS

## Explicit I

I On the Definitions toolbar, click Explicit.
2 In the Settings window for Explicit, locate the Input Entities section.
3 Select the All domains check box.
4 Right-click Explicit I and choose Rename.
5 In the Rename Explicit dialog box, type All domains in the New label text field.
6 Click $\mathbf{O K}$.
Box $I$
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Box Limits section.
3 In the $\mathbf{z}$ minimum text field, type -2 .
4 In the $\mathbf{z}$ maximum text field, type - 1 .
5 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

6 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
7 Right-click Box I and choose Rename.
8 In the Rename Box dialog box, type Ground Plane in the New label text field.
9 Click $\mathbf{0 K}$.
Box 2
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Box Limits section.
3 In the $\mathbf{z}$ minimum text field, type -1 .
4 In the $\mathbf{z}$ maximum text field, type -0.9.
5 Right-click Box 2 and choose Rename.
6 In the Rename Box dialog box, type Oxide in the New label text field.
7 Click $\mathbf{O K}$.
Box 3
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Box Limits section.
3 In the $\mathbf{z}$ minimum text field, type -0.4.

4 In the $\mathbf{z}$ maximum text field, type -0.35 .
5 Right-click Box 3 and choose Rename.
6 In the Rename Box dialog box, type Nitride in the New label text field.
7 Click OK.

Box 4
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Box Limits section.
3 In the $\mathbf{x}$ minimum text field, type -0.1.
4 In the $\mathbf{x}$ maximum text field, type 0.1.
5 In the $y$ minimum text field, type -4.2.
6 In the $\mathbf{z}$ minimum text field, type -0.15 .
7 In the $\mathbf{z}$ maximum text field, type -0.1.
8 Right-click Box 4 and choose Rename.
9 In the Rename Box dialog box, type Electrode in the New label text field.
IO Click OK.
Ball I
I On the Definitions toolbar, click Ball/Disk.
2 In the Settings window for Ball, locate the Ball Center section.
3 In the $\mathbf{z}$ text field, type 1.
4 Locate the Ball Radius section. In the Radius text field, type 0.1.
Box 5
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Box Limits section.
3 In the $y$ maximum text field, type 4.8.
4 In the $\mathbf{z}$ minimum text field, type -0.35 .
5 In the $\mathbf{z}$ maximum text field, type 0.05 .
6 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

Box 6
I Right-click Box 5 and choose Duplicate.
2 In the Settings window for Box, locate the Box Limits section.

3 In the $\mathbf{x}$ minimum text field, type -15 .
4 In the $\mathbf{x}$ maximum text field, type 15.
Difference I
I On the Definitions toolbar, click Difference.
2 In the Settings window for Difference, locate the Input Entities section.
3 Under Selections to add, click Add.
4 In the Add dialog box, In the Selections to add list, choose Ball I and Box 5.
5 Click OK.
6 In the Settings window for Difference, locate the Input Entities section.
7 Under Selections to subtract, click Add.
8 In the Add dialog box, select Box 6 in the Selections to subtract list.
9 Click OK.
10 Right-click Difference I and choose Rename.
II In the Rename Difference dialog box, type Resonator in the New label text field.
I2 Click OK.

## Union I

I On the Definitions toolbar, click Union.
2 In the Settings window for Union, locate the Input Entities section.
3 Under Selections to add, click Add.
4 In the Add dialog box, In the Selections to add list, choose Electrode and Resonator.
5 Click OK.
6 Right-click Union I and choose Rename.
7 In the Rename Union dialog box, type PolySi in the New label text field.
8 Click OK.

## Difference 2

I On the Definitions toolbar, click Difference.
2 In the Settings window for Difference, locate the Input Entities section.
3 Under Selections to add, click Add.
4 In the Add dialog box, select All domains in the Selections to add list.
5 Click OK.
6 In the Settings window for Difference, locate the Input Entities section.

7 Under Selections to subtract, click Add.
8 In the Add dialog box, In the Selections to subtract list, choose Oxide, Nitride, and PolySi.
9 Click OK.
10 Right-click Difference 2 and choose Rename.
II In the Rename Difference dialog box, type Air in the New label text field.
I2 Click OK.

## Adjacent I

I On the Definitions toolbar, click Adjacent.
2 In the Settings window for Adjacent, locate the Input Entities section.
3 Under Input selections, click Add.
4 In the Add dialog box, select Resonator in the Input selections list.
5 Click OK.
6 Right-click Adjacent I and choose Rename.
7 In the Rename Adjacent dialog box, type Resonator Boundaries in the New label text field.

8 Click OK.

## Adjacent 2

I On the Definitions toolbar, click Adjacent.
2 In the Settings window for Adjacent, locate the Input Entities section.
3 Under Input selections, click Add.
4 In the Add dialog box, select Electrode in the Input selections list.
5 Click OK.
6 Right-click Adjacent 2 and choose Rename.
7 In the Rename Adjacent dialog box, type Electrode Boundaries in the New label text field.

8 Click OK.
Adjacent 3
I On the Definitions toolbar, click Adjacent.
2 In the Settings window for Adjacent, locate the Input Entities section.
3 Under Input selections, click Add.
4 In the Add dialog box, select Nitride in the Input selections list.

## 5 Click OK.

6 Right-click Adjacent 3 and choose Rename.
7 In the Rename Adjacent dialog box, type Nitride Boundaries in the New label text field.

8 Click OK.

## Adjacent 4

I On the Definitions toolbar, click Adjacent.
2 In the Settings window for Adjacent, locate the Input Entities section.
3 Under Input selections, click Add.
4 In the Add dialog box, select All domains in the Input selections list.
5 Click OK.
6 Right-click Adjacent 4 and choose Rename.
7 In the Rename Adjacent dialog box, type Geometry Exterior Boundaries in the New label text field.

8 Click OK.

## Difference 3

I On the Definitions toolbar, click Difference.
2 In the Settings window for Difference, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.
4 Locate the Input Entities section. Under Selections to add, click Add.
5 In the Add dialog box, select Resonator Boundaries in the Selections to add list.
6 Click OK.
7 In the Settings window for Difference, locate the Input Entities section.
8 Under Selections to subtract, click Add.
9 In the Add dialog box, select Geometry Exterior Boundaries in the Selections to subtract list.

10 Click OK.
II Right-click Difference 3 and choose Rename.
12 In the Rename Difference dialog box, type Resonator Exterior Boundaries in the New label text field.

I3 Click OK.

## Difference 4

I On the Definitions toolbar, click Difference.
2 In the Settings window for Difference, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.
4 Locate the Input Entities section. Under Selections to add, click Add.
5 In the Add dialog box, select Electrode Boundaries in the Selections to add list.
6 Click OK.
7 In the Settings window for Difference, locate the Input Entities section.
8 Under Selections to subtract, click Add.
9 In the Add dialog box, select Geometry Exterior Boundaries in the Selections to subtract list.
$\mathbf{I O}$ Click OK.
II Right-click Difference 4 and choose Rename.
I2 In the Rename Difference dialog box, type Electrode Exterior Boundaries in the New label text field.

I3 Click OK.
Intersection I
I On the Definitions toolbar, click Intersection.
2 In the Settings window for Intersection, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.
4 Locate the Input Entities section. Under Selections to intersect, click Add.
5 In the Add dialog box, In the Selections to intersect list, choose Resonator Boundaries and Nitride Boundaries.

6 Click OK.
7 Right-click Intersection I and choose Rename.
8 In the Rename Intersection dialog box, type Fixed Boundaries in the New label text field.

9 Click OK.

Box 7
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.

4 Locate the Box Limits section. In the $\mathbf{x}$ minimum text field, type -0.1.
5 In the $\mathbf{x}$ maximum text field, type 0.1 .
6 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

7 Right-click Box 7 and choose Rename.
8 In the Rename Box dialog box, type Symmetry Boundaries in the New label text field.
9 Click OK.

## MATERIALS

Add materials to the model.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select MEMS $>$ Semiconductors $>$ Si - Polycrystalline Silicon.
4 Click Add to Component in the window toolbar.

## MATERIALS

Si - Polycrystalline Silicon (matl)
I In the Model Builder window, under Component I (compl)>Materials click Si Polycrystalline Silicon (matl).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose PolySi.

## ADD MATERIAL

I Go to the Add Material window.
2 In the tree, select MEMS $>$ Insulators $>$ Si3N4 - Silicon nitride.
3 Click Add to Component in the window toolbar.

## MATERIALS

Si3N4 - Silicon nitride (mat2)
I In the Model Builder window, under Component I (compl)>Materials click Si3N4 Silicon nitride (mat2).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Nitride.

ADD MATERIAL
I Go to the Add Material window.
2 In the tree, select MEMS $>$ Insulators $>$ SiO2 - Silicon oxide.
3 Click Add to Component in the window toolbar.

## MATERIALS

## SiO2 - Silicon oxide (mat3)

I In the Model Builder window, under Component I (compl)>Materials click SiO2 Silicon oxide (mat3).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Oxide.

## ADD MATERIAL

I Go to the Add Material window.
2 In the tree, select Built-In>Air.
3 Click Add to Component in the window toolbar.
4 On the Home toolbar, click Add Material to close the Add Material window.

## MATERIALS

Air (mat4)
I In the Model Builder window, under Component I (compl)>Materials click Air (mat4).
2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Air.
Set the air material property to be non-solid, to ensure the interface solves the electrostatics equations in the spatial frame.

4 Click to expand the Material properties section. Locate the Material Properties section. From the Material type list, choose Nonsolid.

## ELECTROMECHANICS (EMI)

## Linear Elastic Material I

I In the Model Builder window, under Component I (compl) right-click Electromechanics (emi) and choose Linear Elastic Material.

2 In the Settings window for Linear Elastic Material, locate the Domain Selection section.
3 From the Selection list, choose Resonator.

## Fixed Constraint I

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Structural>Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.
3 From the Selection list, choose Fixed Boundaries.

## Symmetry I <br> I Right-click Electromechanics (emi) and choose the boundary condition Structural> Symmetry.

2 In the Settings window for Symmetry, locate the Boundary Selection section.
3 From the Selection list, choose Symmetry Boundaries.

## Fixed Mesh 2

I Right-click Electromechanics (emi) and choose the domain setting Deformed Mesh> Fixed Mesh.

2 In the Settings window for Fixed Mesh, locate the Domain Selection section.
3 From the Selection list, choose Oxide.

## Fixed Mesh 3

I Right-click Component I (compI)>Electromechanics (emi)>Fixed Mesh 2 and choose Duplicate.

2 In the Settings window for Fixed Mesh, locate the Domain Selection section.
3 From the Selection list, choose Nitride.

## Fixed Mesh 4

I Right-click Component I (compI)>Electromechanics (emi)>Fixed Mesh 3 and choose Duplicate.

2 In the Settings window for Fixed Mesh, locate the Domain Selection section.
3 From the Selection list, choose Electrode.

## Prescribed Mesh Displacement 2

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Deformed Mesh>Prescribed Mesh Displacement.

2 In the Settings window for Prescribed Mesh Displacement, locate the Boundary Selection section.

3 From the Selection list, choose Symmetry Boundaries.
4 Locate the Prescribed Mesh Displacement section. Clear the Prescribed y displacement check box.

5 Clear the Prescribed z displacement check box.

## Ground I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Ground.

2 In the Settings window for Ground, locate the Boundary Selection section.
3 From the Selection list, choose Resonator Exterior Boundaries.

## Ground 2

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Ground.

2 In the Settings window for Ground, locate the Boundary Selection section.
3 From the Selection list, choose Ground Plane.

## Electric Potential I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Electric Potential.

2 In the Settings window for Electric Potential, locate the Electric Potential section.
3 In the $V_{0}$ text field, type $V d c$.
4 Locate the Boundary Selection section. From the Selection list, choose Electrode Exterior Boundaries.

## MESH I

## Free Triangular I

I In the Model Builder window, under Component I (comp I) right-click Mesh I and choose More Operations>Free Triangular.

2 In the Settings window for Free Triangular, locate the Boundary Selection section.
3 From the Selection list, choose Free Triangular Mesh.
4 Click Build Selected.

## Swept I

I In the Model Builder window, right-click Mesh I and choose Swept.

2 In the Settings window for Swept, click Build Selected.


## STUDY I

I In the Model Builder window, right-click Study I and choose Rename.
2 In the Rename Study dialog box, type Stationary in the New label text field.
3 Click OK.
4 On the Home toolbar, click Compute.

## RESULTS

## 3D Plot Group 3

I On the Results toolbar, click More Data Sets and choose Mirror 3D.
2 On the Results toolbar, click 3D Plot Group.
3 In the Settings window for 3D Plot Group, locate the Data section.
4 From the Data set list, choose Mirror 3D I.

## Volume I

I Right-click 3D Plot Group 3 and choose Volume.
2 In the Settings window for Volume, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>
Electromechanics (Solid Mechanics)>Displacement>
Displacement field (material and geometry frames) $>\mathbf{w}$ - Displacement field, $\mathbf{Z}$ component.

3 Locate the Coloring and Style section. Select the Reverse color table check box.

## Isosurface I

I In the Model Builder window, under Results right-click 3D Plot Group 3 and choose Isosurface.

2 In the Settings window for Isosurface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I> Electromechanics (Electrical Quasistatics) $>$ Electric $>$ V - Electric potential.

3 Locate the Levels section. From the Entry method list, choose Levels.
4 In the Levels text field, type 102030.
5 Locate the Coloring and Style section. From the Color table list, choose Traffic.
6 Clear the Color legend check box.

## 3D Plot Group 3

I Right-click 3D Plot Group 3 and choose Rename.
2 In the Rename 3D Plot Group dialog box, type Biased Displacement in the New label text field.

3 Click OK.
Compare the resulting plot with .

## Frequency Response of a Biased Resonator-3D

## Introduction

Silicon micromechanical resonators have long been used for designing sensors and are now becoming increasingly important as oscillators in the consumer electronics market. In this sequence of models, a surface micromachined MEMS resonator, designed as part of a micromechanical filter, is analyzed in detail. The resonator is based on that developed in Ref. 1.

This model performs a frequency-domain analysis of the structure, which is also biased with its operating DC offset. The analysis begins from the stationary analysis performed in the accompanying model Stationary Analysis of a Biased Resonator-3D; please review this model first.

## Model Definition

The geometry, fabrication, and operation of the device are discussed for the "Stationary Analysis of a Biased Resonator-3D" model.

For the frequency-domain analysis of the structure, consider an applied drive voltage consisting of a 35 V DC offset with a 100 mV drive signal added as a harmonic perturbation. Solve the linearized problem to compute the response of the system.

In general, for resonant structures like this model, a very fine mesh is required to achieve accurate frequency response results. In the interest of saving time, we choose to use a relatively coarse mesh for this tutorial. As a result the resonant peak will shift if a more refined mesh is used.

## DAMPING

To obtain the response of the system, you need to add damping to the model. For this study, assume that the damping mechanism is Rayleigh damping or material damping.

To specify the damping, two material constants are required ( $\alpha_{d M}$ and $\beta_{d K}$ ). For a system with a single degree of freedom (a mass-spring-damper system) the equation of motion with viscous damping is given by

$$
m \frac{d^{2} u}{d t^{2}}+c \frac{d u}{d t}+k u=f(t)
$$

where $c$ is the damping coefficient, $m$ is the mass, $k$ is the spring constant, $u$ is the displacement, $t$ is the time, and $f(t)$ is a driving force.

In the Rayleigh damping model, the parameter $c$ is related to the mass, $m$, and the stiffness, $k$, by the equation:

$$
c=\alpha_{d M} m+\beta_{d K} k
$$

The Rayleigh damping term in COMSOL Multiphysics is proportional to the mass and stiffness matrices and is added to the static weak term.

The damping coefficient, $c$, is frequently defined as a damping ratio or factor, expressed as a fraction of the critical damping, $c_{0}$, for the system such that

$$
\xi=\frac{c}{c_{0}}
$$

where for a system with one degree of freedom

$$
c_{0}=2 \sqrt{k m}
$$

Finally note that for large values of the quality factor, $Q$,

$$
\xi \cong \frac{1}{2 Q}
$$

The material parameters $\alpha_{d M}$ and $\beta_{d K}$ are usually not available in the literature. Often the damping ratio is available, typically expressed as a percentage of the critical damping. It is possible to transform damping factors to Rayleigh damping parameters. The damping factor, $\xi$, for a specified pair of Rayleigh parameters, $\alpha_{d M}$ and $\beta_{d K}$, at the frequency, $f$, is

$$
\xi=\frac{1}{2}\left(\frac{\alpha_{d M}}{2 \pi f}+\beta_{d K} 2 \pi f\right)
$$

Using this relationship at two frequencies, $f_{1}$ and $f_{2}$, with different damping factors, $\xi_{1}$ and $\xi_{2}$, results in an equation system that can be solved for $\alpha_{d M}$ and $\beta_{d K}$ :

$$
\left[\begin{array}{l}
\frac{1}{4 \pi f_{1}} \pi f_{1} \\
\frac{1}{4 \pi f_{2}} \pi f_{2}
\end{array}\right]\left[\begin{array}{l}
\alpha_{d M} \\
\beta_{d K}
\end{array}\right]=\left[\begin{array}{l}
\xi_{1} \\
\xi_{2}
\end{array}\right]
$$

The damping factors for this model are provided as $\alpha_{d M}=4189 \mathrm{~Hz}$ and $\beta_{d K}=8.29 \cdot 10^{-}$ 13 s , consistent with the observed Quality factor of 8000 for the fundamental mode.

## Results and Discussion

Figure 1 shows the frequency response of the resonator. This response can be compared to that shown in Figure 4 in Ref. 1. Although the experimental results in Ref. 1 are from a pair of coupled resonators in this instance, the two resonances are sufficiently separate in frequency space that it is possible to distinguish the two modes. If the details of the external circuits were available, a terminal boundary condition with an attached circuit could be used to compute the electrical response of the system for a more direct comparison with the experimental results.


Figure 1: Frequency response of the fundamental mode of the resonator.

## Reference

1. F.D. Bannon III, J.R. Clark and C.T.-C. Nguyen, "High-Q HF

Microelectromechanical Filters," IEEE Journal of Solid State Circuits, vol. 35, no. 4, pp. 512-526, 2000.

Application Library path: MEMS_Module/Actuators/biased_resonator_3d_freq

## Modeling Instructions

Open the existing stationary study (filename: biased_resonator_3d_basic.mph).
From the File menu, choose Open.
Browse to the model's Application Libraries folder and double-click the file biased_resonator_3d_basic.mph.

Create parameters for the material damping factors.

## GLOBAL DEFINITIONS

## Parameters

I In the Model Builder window, expand the Global Definitions node, then click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| Q | 8000 | 8000 | Resonator quality factor |
| f0 | $8[\mathrm{MHz}]$ | 8 E 6 Hz | Approximate resonance <br> frequency |
| alpha | $4 * \mathrm{pi}^{*} \mathrm{f0} /(3 * \mathrm{Q})$ | 4189 Hz | Damping parameter |
| beta | $1 /\left(6 * \mathrm{pi}^{* f 0 * Q)}\right.$ | $8.289 \mathrm{E}-13 \mathrm{~s}$ | Damping parameter |

Add damping to the physics settings.

## COMPONENT I (COMPI)

In the Model Builder window, expand the Component I (compl) node.

## ELECTROMECHANICS (EMI)

Linear Elastic Material I
In the Model Builder window, expand the Component I (compl)>Electromechanics (emi) node.

## Damping I

I Right-click Linear Elastic Material I and choose Damping.
2 In the Settings window for Damping, locate the Damping Settings section.
3 In the $\alpha_{d M}$ text field, type alpha.
4 In the $\beta_{\mathrm{d} K}$ text field, type beta.
Add a Harmonic Perturbation to the DC bias term, to represent the offset AC drive voltage.

## Harmonic Perturbation I

I In the Model Builder window, under Component I (compl)>Electromechanics (emi) rightclick Electric Potential I and choose Harmonic Perturbation.

2 In the Settings window for Harmonic Perturbation, locate the Electric Potential section.
3 In the $V_{0}$ text field, type 0.1.
Set up the frequency domain study.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Prestressed Analysis, Frequency Domain.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

## Step 2: Frequency-Domain Perturbation

I In the Model Builder window, under Study 2 click Step 2: Frequency-Domain Perturbation.
2 In the Settings window for Frequency-Domain Perturbation, locate the Study Settings section.

3 In the Frequencies text field, type range (7.69[MHz], 0.002[MHz],7.73[MHz]).
4 In the Model Builder window, right-click Study 2 and choose Rename.
5 In the Rename Study dialog box, type Frequency Domain in the New label text field.
6 Click OK.
Disable the default plots.
7 In the Settings window for Study, locate the Study Settings section.

8 Clear the Generate default plots check box.
9 On the Home toolbar, click Compute.
Produce a plot of the frequency response of the system.

## RESULTS

ID Plot Group 4
I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.
3 From the Data set list, choose Frequency Domain/Solution 2 (sol2).

## Point Graph I

I Right-click ID Plot Group 4 and choose Point Graph.
2 Select Point 254 only.
3 In the Settings window for Point Graph, locate the $\mathbf{y}$-Axis Data section.
4 In the Expression text field, type abs (w).
5 On the ID Plot Group 4 toolbar, click Plot.
6 Click the $\mathbf{y}$-Axis Log Scale button on the Graphics toolbar.
ID Plot Group 4
I In the Model Builder window, under Results right-click ID Plot Group 4 and choose Rename.
2 In the Rename ID Plot Group dialog box, type Frequency Domain in the New label text field.

3 Click OK.
Compare the resulting plot with .

## Normal Modes of a Biased Resonator-3D

## Introduction

Silicon micromechanical resonators have long been used for designing sensors and are now becoming increasingly important as oscillators in the consumer electronics market. In this sequence of models, a surface micromachined MEMS resonator, designed as part of a micromechanical filter, is analyzed in detail. The resonator is based on that developed in Ref. 1.

This model performs a modal analysis on the resonator, with and without an applied DC bias. The analysis begins from the stationary analysis performed in the accompanying model Stationary Analysis of a Biased Resonator-3D; please review this model first.

## Model Definition

The geometry, fabrication, and operation of the device are discussed for the "Stationary Analysis of a Biased Resonator-3D" model. In this example it is no longer possible to model half of the geometry using symmetry boundary conditions, because doing so excludes all the antisymmetric vibrational modes. The geometry is therefore mirrored prior to performing the analyses, as shown in Figure 1. Note that the model could still be solved with the original geometry and symmetry boundary conditions, however the antisymmetric modes would be excluded from the solutions.

This model performs a modal analysis on the structure, with and without applied DC voltage biases of different magnitudes. The bias already exists as a parameter in the model so the prestressed eigenfrequency solver needs no adjustment to the physics settings. To compute the unbiased eigenfrequency, the solver settings are adjusted to solve only the structural mechanics problem.

$\underbrace{2}$

Figure 1: Model geometry. In order to capture the anti-symmetric vibrational modes, it is necessary to mirror the symmetric geometry prior to solving the model. The original symmetry plane is in the center of the geoemtry. The resonator itself is shown highlighted.

## Results and Discussion

Figure 2 shows the normal modes of the device, together with the eigenfrequency, in the unbiased state. The lowest three normal modes are symmetric and anti-symmetric bending modes and a torsional mode.

The symmetric bending mode is employed during the operation of the device, and its shape does not change significantly with applied bias. However, the frequency of the mode is reduced significantly by the applied bias, an effect known as spring softening. The spring softening effect can be seen in detail in Figure 2. A clear decrease in the resonant frequency is evident with increasing bias voltage. This figure should be compared with Figure 16 of Ref. 1 which shows measured experimental data for the same device. Data extracted from Ref. 1 is shown in Figure 3 along with the simulation results. The agreement between the model and the data is excellent.


Eigenfrequency $=2.19 \mathrm{E} 7 \mathrm{~Hz}$ Volume: Total displacement ( $\mu \mathrm{m}$ )


Eigenfrequency $=2.691 \mathrm{E} 7 \mathrm{~Hz}$ Volume: Total displacement ( $\mu \mathrm{m}$ )


Figure 2: Normal modes of the unbiased device, together with the frequency of the mode.


Figure 3: Resonant frequency of the first normal mode (a symmetric bending mode) as a function of applied DC bias. Both the COMSOL simulation data and the experimental data from Ref. 1 are shown in the plot.

## Reference

1. F.D. Bannon III, J.R. Clark and C.T.-C. Nguyen, "High-Q HF

Microelectromechanical Filters," IEEE Journal of Solid State Circuits, vol. 35, no. 4, pp. 512-526, 2000.

Application Library path: MEMS_Module/Actuators/biased_resonator_3d_modes

## Modeling Instructions

## ROOT

Open the existing stationary study (filename: biased_resonator_3d_basic.mph).
I From the File menu, choose Open.

2 Browse to the model's Application Libraries folder and double-click the file biased_resonator_3d_basic.mph.

## RESULTS

## Biased Displacement

Mirror the geometry so that asymmetric eigenmodes can be modeled.

## GEOMETRY I

## Mirror I (mirl)

I On the Geometry toolbar, click Transforms and choose Mirror.
2 In the Settings window for Mirror, locate the Normal Vector to Plane of Reflection section.
3 In the $\mathbf{z}$ text field, type 0 .
4 In the $\mathbf{x}$ text field, type 1.
5 Click in the Graphics window and then press Ctrl+A to select both objects.
6 Locate the Input section. Select the Keep input objects check box.

## 7 Click Build All Objects.

8 Click the Zoom Extents button on the Graphics toolbar.
Import experimental data into the model for comparison with the simulation.

## DEFINITIONS

## Interpolation I (intI)

I On the Home toolbar, click Functions and choose Local>Interpolation.
2 In the Settings window for Interpolation, locate the Definition section.
3 From the Data source list, choose File.
4 Click Browse.
5 Browse to the model's Application Libraries folder and double-click the file biased_resonator_3d_modes_experiment.txt.
6 Click Import.
7 Locate the Units section. In the Arguments text field, type Hz .
8 In the Function text field, type V.
9 Locate the Interpolation and Extrapolation section. From the Extrapolation list, choose Specific value.

10 In the Value outside range text field, type NaN .
Disable the symmetry node to allow anti-symmetric nodes.

## ELECTROMECHANICS (EMI)

## Symmetry I

I In the Model Builder window, expand the Component I (compl)>Electromechanics (emi) node.

2 Right-click Symmetry I and choose Disable.

## ROOT

Add a study to compute the unbiased vibrational modes.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Custom Studies> Eigenfrequency.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

## Step I: Eigenfrequency

Solve for the first three modes.

I In the Model Builder window, click Step I: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Study Settings section.
3 Select the Desired number of eigenfrequencies check box.
4 In the associated text field, type 3.
Disable the electric potential and mesh displacement degrees of freedom to solve only the structural problem. This will give the vibrational modes in the absence of an electric field.

## Solution 2 (sol2)

I On the Study toolbar, click Show Default Solver.
2 In the Model Builder window, expand the Solution 2 (sol2) node, then click Dependent Variables I.

3 In the Settings window for Dependent Variables, locate the General section.
4 From the Defined by study step list, choose User defined.
5 In the Model Builder window, expand the Study $2>$ Solver Configurations> Solution 2 (sol2)>Dependent Variables I node, then click Electric potential (compI.V).

6 In the Settings window for Field, locate the General section.
7 Clear the Solve for this field check box.
8 Clear the Store in output check box.
9 In the Model Builder window, under Study 2>Solver Configurations>Solution 2 (sol2)> Dependent Variables I click Spatial coordinates (compl.xyz).

10 In the Settings window for Field, locate the General section.
II Clear the Solve for this field check box.
$\mathbf{1 2}$ Clear the Store in output check box.
I3 In the Model Builder window, right-click Study 2 and choose Rename.
14 In the Rename Study dialog box, type Unbiased Eigenfrequency in the New label text field.

15 Click OK.
16 In the Settings window for Study, locate the Study Settings section.
17 Clear the Generate default plots check box.
18 On the Study toolbar, click Compute.
Change the data set frame to show results in the material frame. This allows the use of the deformation plot attribute.

## RESULTS

Unbiased Eigenfrequency/Solution 2 (sol2)
I In the Model Builder window, expand the Results>Data Sets node, then click Unbiased Eigenfrequency/Solution 2 (sol2).
2 In the Settings window for Solution, locate the Solution section.
3 From the Frame list, choose Material (X, Y, Z).
Create a plot that shows the unbiased modes.

## 3D Plot Group 4

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Settings window for 3D Plot Group, locate the Data section.

3 From the Data set list, choose Unbiased Eigenfrequency/Solution 2 (sol2).

## Volume I

I Right-click 3D Plot Group 4 and choose Volume.
2 In the Settings window for Volume, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Model>Component I> Electromechanics (Solid Mechanics)>Displacement>emi.disp - Total displacement.

3 Locate the Coloring and Style section. Clear the Color legend check box.

## 3D Plot Group 4

I Right-click Results>3D Plot Group 4>Volume I and choose Deformation.
2 In the Model Builder window, under Results right-click 3D Plot Group 4 and choose Rename.

3 In the Rename 3D Plot Group dialog box, type Unbiased Modes in the New label text field.

4 Click OK.
Compare the mode shapes with those shown in for all the modes computed. To switch between the modes click Unbiased Modes and choose a different value from the Eigenfrequency list.
Add a Prestressed Analysis, Eigenfrequency study.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Prestressed Analysis, Eigenfrequency.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 3

## Step I: Stationary

I In the Model Builder window, right-click Study 3 and choose Rename.
2 In the Rename Study dialog box, type Biased Eigenfrequency in the New label text field.

3 Click OK.
Create a parametric sweep over DC bias voltage.

## Parametric Sweep

On the Study toolbar, click Parametric Sweep.

## BIASED EIGENFREQUENCY

## Parametric Sweep

I In the Settings window for Parametric Sweep, locate the Study Settings section.

## 2 Click Add.

3 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| Vdc |  |  |

4 Click Range.
5 In the Range dialog box, type 5 in the Start text field.
6 In the Stop text field, type 45.
7 In the Step text field, type 5.
8 Click Add.
Solve for only the first eigenfrequency.

## Step 2: Eigenfrequency

I In the Model Builder window, under Biased Eigenfrequency click Step 2: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Study Settings section.
3 Select the Desired number of eigenfrequencies check box.
4 In the associated text field, type 1.
Disable the default plots.
5 In the Model Builder window, click Biased Eigenfrequency.
6 In the Settings window for Study, locate the Study Settings section.
7 Clear the Generate default plots check box.
8 On the Study toolbar, click Compute.
Create a plot of eigenfrequency vs. applied DC voltage.

## RESULTS

ID Plot Group 5
I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.

3 From the Data set list, choose Biased Eigenfrequency/Parametric Solutions I (sol5).

## Point Graph I

I Right-click ID Plot Group 5 and choose Point Graph.
2 Select Point 1 only.
3 In the Settings window for Point Graph, locate the $\boldsymbol{y}$-Axis Data section.
4 In the Expression text field, type emi.freq.
5 Locate the x-Axis Data section. From the Axis source data list, choose Outer solutions.
6 Click to expand the Coloring and style section. Locate the Coloring and Style section. Find the Line style subsection. From the Line list, choose None.
7 Find the Line markers subsection. From the Marker list, choose Square.
8 From the Positioning list, choose In data points.
9 Click to expand the Legends section. Select the Show legends check box.
10 From the Legends list, choose Manual.
II In the table, enter the following settings:

| Legends |
| :--- |
| COMSOL Solution |

## Point Graph 2

I Right-click Results>ID Plot Group 5>Point Graph I and choose Duplicate.
2 In the Settings window for Point Graph, locate the Data section.
3 From the Data set list, choose Unbiased Eigenfrequency/Solution 2 (sol2).
4 From the Eigenfrequency selection list, choose First.
5 Locate the Coloring and Style section. From the Color list, choose Blue.
6 Locate the Legends section. Clear the Show legends check box.

## Global I

I In the Model Builder window, under Results right-click ID Plot Group 5 and choose Global.

2 In the Settings window for Global, locate the $\mathbf{y}$-Axis Data section.
3 In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| int1 (Vdc) |  |  |

4 Locate the x-Axis Data section. From the Axis source data list, choose Outer solutions.
5 From the Parameter list, choose Expression.
6 In the Expression text field, type Vdc.
7 Click to expand the Legends section. From the Legends list, choose Manual.
8 In the table, enter the following settings:

## Legends

Experiment: Bannon et. al.
ID Plot Group 5
I In the Model Builder window, under Results click ID Plot Group 5.
2 In the Settings window for ID Plot Group, click to expand the Title section.
3 From the Title type list, choose Manual.
4 In the Title text area, type Eigenfrequency vs. DC voltage.
5 Locate the Plot Settings section. Select the $\mathbf{x}$-axis label check box.
6 In the associated text field, type DC Bias (V).
7 Select the $\mathbf{y}$-axis label check box.
8 In the associated text field, type Resonant Frequency ( Hz ).
9 Right-click Results> ID Plot Group 5 and choose Rename.
10 In the Rename ID Plot Group dialog box, type Eigenfrequency vs DC Voltage in the New label text field.

II Click OK.
Compare this plot with that in. Note the spring softening effect.

## Pull-In Voltage for a Biased Resonator-3D

## Introduction

Silicon micromechanical resonators have long been used for designing sensors and are now becoming increasingly important as oscillators in the consumer electronics market. In this sequence of models, a surface micromachined MEMS resonator, designed as part of a micromechanical filter, is analyzed in detail. The resonator is based on that developed in Ref. 1.

This model performs a pull-in analysis of the structure, to predict the point at which the biased system becomes unstable. The analysis begins from the stationary analysis performed in the accompanying model Stationary Analysis of a Biased Resonator-3D; please review this model first.

## Model Definition

The geometry, fabrication, and operation of the device are discussed for the "Stationary Analysis of a Biased Resonator-3D" model.

This model computes the pull-in voltage for the resonator by solving an inverse problem. The z -coordinate of the resonator midpoint is computed using an integration operator (intop1). The inverse problem that COMSOL solves computes the DC voltage that must be applied to the beam in order to move the midpoint to a set z -coordinate, zset. This is achieved by adding a global equation for the DC voltage, VdcSP, applied to the resonator. The equation intop1 ( $z$ ) - zset=0 is solved to determine the value of VdcSP. This means that VdcSP is adjusted until the midpoint of the resonator has a $z$-coordinate given by the set value, zset. Essentially COMSOL is being asked to find the voltage that allows the beam to exist in equilibrium (stable or unstable) at a given displacement. Solving the problem in this way avoids complications with trying to solve a problem with no solution (which is what happens if the voltage is continuously ramped up eventually exceeding the pull-in voltage). The result of the analysis is a displacement versus voltage plot, with a minimum at the pull-in voltage. Note that for a linear spring, the pull-in displacement corresponds to $1 / 3$ of the gap distance. Although the inclusion of geometric nonlinearities in the solid mechanics solver means that the pull-in displacement changes slightly from this value, it is usually most efficient to search around this point for the pull-in voltage.

## Results and Discussion

Figure 1 shows the voltage-displacement curve for the resonator at equilibrium. The $y$ coordinate at which the pull in occurs corresponds to a displacements around $1 / 3$ of the gap size. The pull-in voltage is 59.1 V .


Figure 1: Voltage required to achieve a set displacement versus the target displacement. The pull-in voltage is the minimum of the plot: 59.4 V .


Figure 2: $z$-displacement of the resonator at pull-in. The displacement at pull-in is 75 nm . For a linear spring the displacement at pull in would be 66 nm .

Figure 2 shows the $z$-displacement of the resonator at the pull-in voltage. The maximum displacement at pull-in is 75 nm . This is comparable to the linear spring value of 66 nm .

## Notes About the COMSOL Implementation

To compute the voltage required to generate the desired displacement of the beam, use a global equation. A common use of global equations is for computing the value of a dependent variable based on an ordinary differential equation in the dependent variable itself. However, it is also possible to couple a global equation with the other PDEs in the model as a powerful tool to solve certain kinds of inverse problems. This model uses a global equation to compute the potential applied to the drive electrode. The equation takes the form

$$
z_{0}=z_{\text {set }}
$$

where $z_{0}$ is the $z$-coordinate of the midpoint of the beam's underside and $z_{\text {set }}$ is the desired $z$-coordinate. COMSOL Multiphysics computes the voltage to satisfy the constraint implied by the above equation. Note that the large difference in scale between the set-
point displacement $\left(10^{-7} \mathrm{~m}\right)$ and the applied voltages $\left(10^{2} \mathrm{~V}\right)$ means that care must be taken with the dependent variable scaling in the solver settings.

Reference

1. F.D. Bannon III, J.R. Clark and C.T.-C. Nguyen, "High-Q HF

Microelectromechanical Filters," IEEE Journal of Solid State Circuits, vol. 35, no. 4, pp. 512-526, 2000.

Application Library path: MEMS_Module/Actuators/ biased_resonator_3d_pull_in

## Modeling Instructions

Open the existing stationary study (filename: biased_resonator_3d_basic.mph).
From the File menu, choose Open.
Browse to the application's Application Libraries folder and double-click the file biased_resonator_3d_basic.mph.

Add a parameter to set the z -coordinate of the midpoint of the resonator.

## GLOBAL DEFINITIONS

## Parameters

I In the Model Builder window, expand the Global Definitions node, then click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| zset | $100[\mathrm{~nm}]$ | IE-7 m | Set point z-coordinate |

Add an integration operator to compute the actual displacement.

## DEFINITIONS

Integration I (intop I)
I On the Definitions toolbar, click Component Couplings and choose Integration.

2 In the Settings window for Integration, locate the Source Selection section.
3 From the Geometric entity level list, choose Point.
4 Select Point 253 only.
Change the drive potential to the value VdcSP - which will be solved for in a global equation.

ELECTROMECHANICS (EMI)

## Electric Potential I

I In the Model Builder window, expand the Component I (compl)>Electromechanics (emi) node, then click Electric Potential I.

2 In the Settings window for Electric Potential, locate the Electric Potential section.
3 In the $V_{0}$ text field, type VdcSP.
Add a global equation to compute the voltage for a given displacement, VdcSP.
4 In the Model Builder window's toolbar, click the Show button and select
Advanced Physics Options in the menu.
Global Equations I
I On the Physics toolbar, click Global and choose Global Equations.
2 In the Settings window for Global Equations, locate the Global Equations section.
3 In the table, enter the following settings:

| Name | f(u,ut,utt,t) (I) | Initial value <br> $\left(\mathbf{u} \_\mathbf{0}\right)(\mathbf{1 )}$ | Initial value <br> $\left(\mathbf{u} \_\mathbf{t 0}\right)(\mathbf{1 / s )}$ | Description |
| :--- | :--- | :--- | :--- | :--- | :--- |
| VdcSP | intop1 (z)-zset | 0 | 0 | Applied bias required <br> to reach zset (V) |

Set up a parametric sweep over zset.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies>Stationary.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

Step I: Stationary
I In the Model Builder window, under Study 2 click Step I: Stationary.
2 In the Settings window for Stationary, click to expand the Study extensions section.
3 Locate the Study Extensions section. Select the Auxiliary sweep check box.
4 Click Add.
5 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| zset |  |  |

6 Click Range.
7 In the Range dialog box, type 120e-9 in the Start text field.
8 In the Step text field, type 2e-9.
9 In the Stop text field, type 140e-9.
10 Click Replace.
The dependent variables require scaling correctly in order to assist the solver.

## Solution 2 (sol2)

I On the Study toolbar, click Show Default Solver.
2 In the Model Builder window, expand the Solution 2 (sol2) node, then click Dependent Variables I.
3 In the Settings window for Dependent Variables, locate the General section.
4 From the Defined by study step list, choose User defined.
5 In the Model Builder window, expand the Study 2>Solver Configurations> Solution 2 (sol2)>Dependent Variables I node, then click Electric potential (comp I.V).

6 In the Settings window for Field, locate the Scaling section.
7 From the Method list, choose Manual.
8 In the Scale text field, type 100.
9 In the Model Builder window, under Study $\mathbf{2 > S o l v e r ~ C o n f i g u r a t i o n s > S o l u t i o n ~} 2$ (sol2)> Dependent Variables I click Spatial coordinates (compl.xyz).

10 In the Settings window for Field, locate the Scaling section.
II From the Method list, choose Manual.
I2 In the Scale text field, type 1e-6.

13 In the Model Builder window, under Study 2>Solver Configurations>Solution 2 (sol2)> Dependent Variables I click Applied bias required to reach zset (V) (compI.ODEI).

14 In the Settings window for State, locate the Scaling section.
15 From the Method list, choose Manual.
16 In the Scale text field, type 100.
The problem is highly non-linear, so the solver settings need to be adjusted accordingly.
I7 In the Model Builder window, expand the Study 2>Solver Configurations> Solution 2 (sol2)>Stationary Solver I node.

18 Right-click Study 2>Solver Configurations>Solution 2 (sol2)>Stationary Solver I and choose Fully Coupled.

19 In the Settings window for Fully Coupled, locate the General section.
20 From the Linear solver list, choose Direct.
$\mathbf{2 1}$ Click to expand the Method and termination section. Locate the Method and Termination section. From the Nonlinear method list, choose Automatic highly nonlinear (Newton).

2 In the Model Builder window, right-click Study 2 and choose Rename.
23 In the Rename Study dialog box, type Pull In in the New label text field.
24 Click OK.
25 On the Study toolbar, click Compute.

## RESULTS

## Displacement (emi) I

Determine the pull-in voltage by plotting VdcSP vs. zset.

## ID Plot Group 6

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.
3 From the Data set list, choose Pull In/Solution 2 (sol2).

## Global I

I Right-click ID Plot Group 6 and choose Global.
2 In the Settings window for Global, click Replace Expression in the upper-right corner of the $\mathbf{y}$-axis data section. From the menu, choose Component I>Electromechanics>VdcSP Applied bias required to reach zset (V).

3 Locate the x-Axis Data section. From the Parameter list, choose Expression.
4 In the Expression text field, type zset.

## ID Plot Group 6

I In the Model Builder window, under Results right-click ID Plot Group 6 and choose Rename.

2 In the Rename ID Plot Group dialog box, type Pull-In Plot in the New label text field.
3 Click OK.
4 On the Pull-In Plot toolbar, click Plot.
5 Click the Zoom Extents button on the Graphics toolbar.
Compare the resulting plot with. The pull in voltage is the minimum of the curve: 59.4 $V$ at zset $=126 \mathrm{~nm}$.

Now look at the displacement at pull in. The default plot group can be used.

## Displacement (emi) I

I In the Model Builder window, under Results click Displacement (emi) I.
2 In the Settings window for 3D Plot Group, locate the Data section.
3 From the Parameter value (zset) list, choose I.24E-7.
4 On the Displacement (emi) I toolbar, click Plot.
Compare the resulting plot with . The displacement at pull-in is 75 nm .

## Capacitive Pressure Sensor

## Introduction

Capacitive pressure sensors are gaining market share over their piezoresistive counterparts since they consume less power, are usually less temperature sensitive and have a lower fundamental noise floor. This model performs an analysis of a hypothetical sensor design discussed in Ref. 1 , using the electromechanics interface. The effect of a rather poor choice of packaging solution on the performance of the sensor is also considered. The results emphasize the importance of considering packaging in the MEMS design process.

## Model Definition

The model geometry is shown in Figure 1. The pressure sensor is part of a silicon die that has been bonded to a metal plate at $70^{\circ} \mathrm{C}$. Since the geometry is symmetric, only a single quadrant of the geometry needs to be included in the model, and it is possible to use symmetry boundary condition.


Figure 1: The model geometry. Left: The symmetric device geometry, with one quadrant highlighted in blue, showing the symmetry planes. Right: In COMSOL only the highlighted quadrant is modeled, and the symmetry boundary condition is used on the cross section walls.

A detailed 2D section through the functional part of the device is shown in Figure 2. A thin membrane is held at a fixed potential of 1 V . The membrane is separated from a ground plane chamber sealed under high vacuum. The sides of the chamber are insulating to prevent a connection between the membrane and the ground plane (for simplicity the insulating layer is not modeled explicitly in the COMSOL model-this approximation has little effect on the results of the study.).


Figure 2: Cross section through the device showing the capacitor. The vertical axis has been expanded to emphasize the gap.

When the pressure outside of the sealed chamber changes, the pressure difference causes the membrane to deflect. The thickness of the air gap now varies across the membrane and its capacitance to ground therefore changes. This capacitance is then monitored by an interfacing circuit, such as the switched capacitor amplifier circuit discussed in Ref. 1.

Thermal stresses are introduced into the structure as a result of the thermal conductivity mismatch between the silicon die and the metal plate, and the elevated temperature used for the bonding process. These stresses change the deformation of the diaphragm in response to applied pressures and alter the response of the sensor. In addition, because the stresses are temperature dependent, they introduce an undesired temperature dependence to the device output.

Initially the sensor is analyzed in the case where there are no packaging stresses. Then the effect of the packaging stress is considered. First, the device response at fixed temperature is evaluated with the additional packaging stress. Finally the temperature dependence of the device response at a fixed applied pressure is assessed.

## Results and Discussion

Figure 3 shows the deformation of the membrane when a pressure of 25 kPa is applied to it, in the absence of packaging stresses. Figure 4 shows the potential on a plane located between the plates. The deformation of the membrane is of the form expected, and results in a nonuniform potential between the plates.


Figure 3: Quadrant deflection when the pressure difference across the membrane is 25 kPa . As expected the deflection is greatest in the center of the membrane


Figure 4: Electric potential in the air chamber, plotted on a slice between the two plates of the capacitor. The potential has become nonuniform as a result of the pressure-induced deformation of the diaphragm.


Figure 5: Maximum and mean displacement of the membrane as a function of the applied pressure.


Figure 6: Capacitance of the membrane as a function of applied pressure, both with and without the packaging stresses. The linearized zero pressure capacitance variation, taken from Ref. 1 , is also shown for comparison.

Figure 5 shows the mean and maximum displacements of the membrane as a function of applied pressure. At an applied pressure of 10 kPa the diaphragm displacement in the center is $0.89 \mu \mathrm{~m}$. The average displacement of the diaphragm is $0.27 \mu \mathrm{~m}$. These values are in good agreement with the approximate model given in Ref. 1 (maximum displacement $0.93 \mu \mathrm{~m}$, average displacement $0.27 \mu \mathrm{~m}$ ).

Figure 6 shows that the capacitance of the device increases nonlinearly with applied pressure. The gradient of the curve plotted is a measure of the sensitivity of the sensor. At zero applied pressure the sensitivity of the model ( $1 / 4$ of the whole sensor) is $7.3 \times 10^{-6}$ $\mathrm{pF} / \mathrm{Pa}$ (compare to the value of $6.5 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}$ given in Ref. 1 ). The device sensitivity is therefore $29 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}$ (compare to $26 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}$. calculated in Ref. 1). Assuming the interfacing electronics use the switched capacitor amplifier circuit presented in Ref. 1 this corresponds to a sensor transfer function of $29 \mu \mathrm{~V} / \mathrm{Pa}$ (compared to $26 \mu \mathrm{~V} / \mathrm{Pa}$ from Ref. 1). Using a smaller pressure step to produce the plot improves the agreement leading to a response at the origin of $6.7 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}\left(27 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}\right.$ for the device, corresponding to $27 \mu \mathrm{~V} / \mathrm{Pa}$ ). The response is nonlinear, so that at 20 kPa the model output is $14.3 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}$ (device output $57 \mathrm{pF} / \mathrm{Pa}$ or $\left.57 \mu \mathrm{~V} / \mathrm{Pa}\right)$ ). This nonlinear response adds to the complexity of designing the interfacing circuitry. Note that, for comparison with these figures, the circuitry proposed in Ref. 1 , has a noise floor corresponding to a capacitance of $17 \times 10^{-6} \mathrm{pF}$, or 0.6 Pa at zero applied pressure (assuming an average of 100 consecutive measurements). This resolution is approximately four times the fundamental sensitivity of the device imposed by mechanical noise from thermal fluctuations.

Next the response of the device is considered when packaging stresses are present in the model. For this part of the discussion it is assumed that the device is operated at $20^{\circ} \mathrm{C}$ and that the system was stress and displacement free at the bonding temperature $\left(70^{\circ} \mathrm{C}\right)$. Figure 7 shows the displacement of the structure at the room temperature operating point, with an applied pressure of 25 kPa . The membrane displacement at its center is shown in Figure 5. The complex interaction between the thermal stresses and the stresses introduced as a result of the applied pressure has resulted in both an initial offset displacement and an increased dependence of the displacement on the pressure.


Figure 7: The displacement of the structure due to an applied pressure of 25 kPa when packaging stresses are also included in the model. Displacements are shown at the operating temperature of $20^{\circ} \mathrm{C}$, and are assumed to be zero at the die bonding temperature of $70^{\circ} \mathrm{C}$.


Figure 8: Temperature dependence of the capacitance of the packaged device. The capacitance varies with temperature as a result of temperature induced changes in the packaging stress within the diaphragm.

The response of the device with the additional packaging stresses is shown in Figure 6. At zero applied pressure the sensitivity of the COMSOL model has increased from $6.5 \times 10^{-}$ $6 \mathrm{pF} / \mathrm{Pa}$ to $10 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}\left(40 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}\right.$ for the entire device $)$. The effect is even more pronounced at a pressure of 20 kPa , where the model that includes thermal stresses shows a pressure sensitivity of $25 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}(100 \mathrm{pF} / \mathrm{Pa}$ for the entire device $)$ compared to the unstressed value of $14.3 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}$. The sensitivity of the device to pressure has almost doubled. While this effect might seem desirable, an unwanted dependence on temperature has been introduced into the device response. Since the thermal stresses are temperature dependent, the response of the device is also now temperature dependent. The final study in the model assesses this issue.

Figure 8 shows the capacitance of the device, with an applied pressure of 20 kPa , as the temperature is varied. The temperature sensitivity of the model response is given by the gradient of this curve, approximately $3.5 \times 10^{-3} \mathrm{pF} / \mathrm{K}\left(14 \times 10^{-3} \mathrm{pF} / \mathrm{K}\right.$ for the whole device). With a pressure sensitivity of $25 \times 10^{-6} \mathrm{pF} / \mathrm{Pa}$ at 20 kPa (for a single quadrant of the device) this corresponds to an equivalent pressure of $140 \mathrm{~Pa} / \mathrm{K}$ in the sensor output. Compared to the unstressed performance of the sensor (0.6 Pa with the circuit proposed in Ref. 1) this number is very large. The model shows the importance of carefully considering the packaging in the MEMS design process.

## Reference

1. V. Kaajakari, Practical MEMS, Small Gear Publishing, Las Vegas, 2009.

Application Library path: MEMS_Module/Sensors/capacitive_pressure_sensor

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Electromechanics (emi).
3 Click Add.

## 4 Click Study.

5 In the Select Study tree, select Preset Studies>Stationary.

## 6 Click Done.

For convenience, the device geometry is inserted from an existing file. You can read the instructions for creating the geometry in the .

## GEOMETRY I

I On the Geometry toolbar, click Insert Sequence.
2 Browse to the model's Application Libraries folder and double-click the file capacitive_pressure_sensor_geom_sequence.mph.

3 On the Geometry toolbar, click Build AlI.


Add parameters to the model. These will be used subsequently to perform parametric studies.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.

3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| p0 | $20[\mathrm{kPa}]$ | 2 E4 Pa | Pressure |
| T0 | $20[\mathrm{degC}]$ | 293.2 K | Operating temperature |
| Tref | $70[\mathrm{degC}]$ | 343.2 K | Die Bonding temperature |

SI units or their multiples, such as Pa and kPa , as well as non-SI units, such as degrees Celsius can be entered in the COMSOL Desktop enclosed by square brackets.

Next, add a component coupling operator to compute a derived global quantity from the model. These operators can be convenient for results processing and COMSOL's solvers can also use them during the solution process, for example to include integral quantities in the equation system. Here, an Average operator is added so that the average displacement of the diaphragm can be computed and a point integration is used to make available the displacement of the center point of the diaphragm.

## DEFINITIONS

## Average I (aveopl)

I On the Definitions toolbar, click Component Couplings and choose Average.
2 In the Settings window for Average, locate the Source Selection section.
3 From the Geometric entity level list, choose Boundary.
4 Select Boundary 12 only.
Integration I (intop I)
I On the Definitions toolbar, click Component Couplings and choose Integration.
2 In the Settings window for Integration, locate the Source Selection section.
3 From the Geometric entity level list, choose Point.
4 Select Point 4 only.
Next, define selections to simplify the set up of materials and physics.
Box 1
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.
4 Locate the Box Limits section. In the $\mathbf{x}$ maximum text field, type 1e-6.

5 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

6 Right-click Box I and choose Rename.
7 In the Rename Box dialog box, type YZ Symmetry Plane in the New label text field.
8 Click OK.
Box 2
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.
4 Locate the Box Limits section. In the y maximum text field, type 1e-6.
5 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

6 Right-click Box 2 and choose Rename.
7 In the Rename Box dialog box, type XZ Symmetry Plane in the New label text field.
8 Click OK.
Box 3
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Box Limits section.
3 In the $\mathbf{z}$ maximum text field, type -100 [um].
4 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.
5 Right-click Box 3 and choose Rename.
6 In the Rename Box dialog box, type Steel Base in the New label text field.
7 Click OK.

## Explicit I

I On the Definitions toolbar, click Explicit.
2 Select Domain 3 only.
3 Right-click Explicit I and choose Rename.
4 In the Rename Explicit dialog box, type Cavity in the New label text field.
5 Click OK.

## Explicit 2

I On the Definitions toolbar, click Explicit.

2 In the Settings window for Explicit, locate the Input Entities section.
3 Select the All domains check box.
4 Right-click Explicit 2 and choose Rename.
5 In the Rename Explicit dialog box, type All domains in the New label text field.
6 Click OK.

## Difference I

I On the Definitions toolbar, click Difference.
2 In the Settings window for Difference, locate the Input Entities section.
3 Under Selections to add, click Add.
4 In the Add dialog box, select All domains in the Selections to add list.
5 Click OK.
6 In the Settings window for Difference, locate the Input Entities section.
7 Under Selections to subtract, click Add.
8 In the Add dialog box, select Cavity in the Selections to subtract list.
9 Click OK.
10 Right-click Difference I and choose Rename.
II In the Rename Difference dialog box, type Linear Elastic in the New label text field.

## I2 Click OK.

Next, add the physics settings to the model. These include the pressure forces acting on the sensor, the applied sense voltage, and other appropriate boundary conditions.

## ELECTROMECHANICS (EMI)

In the Electromechanics interface, use a Linear Elastic Material node to solve the equations of structural mechanics only. The electric field does not penetrate these regions.

## Linear Elastic Material I

I In the Model Builder window, under Component I (compl) right-click Electromechanics (emi) and choose Linear Elastic Material.

2 In the Settings window for Linear Elastic Material, locate the Domain Selection section.
3 From the Selection list, choose Linear Elastic.
Apply the structural symmetry boundary condition on the symmetry boundaries.

## Symmetry I

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Structural $>$ Symmetry.
2 In the Settings window for Symmetry, locate the Boundary Selection section.
3 From the Selection list, choose XZ Symmetry Plane.

## Symmetry 2

I Right-click Electromechanics (emi) and choose the boundary condition Structural> Symmetry.
2 In the Settings window for Symmetry, locate the Boundary Selection section.

## 3 From the Selection list, choose YZ Symmetry Plane.

Note that the electrical symmetry boundary condition (the Zero Charge feature) is applied by default.

The motion of the structure is constrained in most directions by the structural symmetry boundary conditions. However, the whole device can still slide up and down the $z$-axis. Apply a point constraint to prevent this.

## Prescribed Displacement 2

I Right-click Electromechanics (emi) and choose Points>Prescribed Displacement.
2 Select Point 44 only.
3 In the Settings window for Prescribed Displacement, locate the Prescribed Displacement section.

4 Select the Prescribed in $\mathbf{z}$ direction check box.
Apply a Boundary Load to represent the pressure acting on the surface of the diaphragm.

## Boundary Load I

I Right-click Electromechanics (emi) and choose the boundary condition Structural> Boundary Load.
2 Select Boundary 13 only.
3 In the Settings window for Boundary Load, locate the Force section.
4 From the Load type list, choose Pressure.
5 In the $p$ text field, type po.
Moving mesh boundary conditions must be applied on boundaries where the air domain deforms and where the default Electromechanical Interface boundary condition does not apply. The Electromechanical Interface boundary condition automatically obtains its selection from the interface between structural and deforming air domains.

It applies the appropriate electrical forces to the structural layer and constrains the deformation of the air domain to be equal to that of the structure.

## Prescribed Mesh Displacement I

I In the Model Builder window, under Component I (compI)>Electromechanics (emi) click Prescribed Mesh Displacement I.

2 In the Settings window for Prescribed Mesh Displacement, locate the Prescribed Mesh Displacement section.
3 Clear the Prescribed z displacement check box.
Doing this allows the membrane (and the mesh) to move in the $z$-direction.
Add Terminal and Ground features to the model to apply boundary conditions for the electrostatics parts of the problem.

## Terminal I

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Electrical>Terminal.

2 Select Boundary 12 only.
3 In the Settings window for Terminal, locate the Terminal section.
4 From the Terminal type list, choose Voltage.
The default value of 1 V is fine in this instance.

## Ground I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Ground.

2 Select Boundary 9 only.
The pressure sensor consists of a silicon die with an enclosed cavity held at a low pressure. The pressure sensor is bonded onto a cylindrical steel plate during the packaging process. COMSOL includes a Material Library with many predefined material properties. This model uses a predefined material for the steel plate, but sets up the silicon as a user-defined material with isotropic material parameters to allow comparison with. The cavity also needs 'material' properties (to define the relative permittivity) and a user defined material is used to set the relative permittivity to 1 in this region.

## MATERIALS

Material I (matl)
I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.
3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Relative permittivity | epsilonr | 11.7 | I | Basic |
| Young's modulus | E | $170[\mathrm{GPa}]$ | Pa | Basic |
| Poisson's ratio | nu | 0.06 | I | Basic |
| Density | rho | 2330 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |

4 Right-click Component I (compl)>Materials>Material I (matI) and choose Rename.
5 In the Rename Material dialog box, type Silicon in the New label text field.

## 6 Click OK.

By default, the silicon is in all domains. Some of these selections will be overridden as other materials are added.

## Material 2 (mat2)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Cavity.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Relative permittivity | epsilonr | 1 | I | Basic |

5 Click to expand the Material properties section. Locate the Material Properties section. From the Material type list, choose Nonsolid.

6 Right-click Component I (compl)>Materials>Material 2 (mat2) and choose Rename.
7 In the Rename Material dialog box, type Vacuum in the New label text field.
8 Click OK.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select Built-In>Steel AISI 4340.

4 Click Add to Component in the window toolbar.
5 On the Home toolbar, click Add Material to close the Add Material window.

## MATERIALS

Steel AISI 4340 (mat3)
I In the Model Builder window, under Component I (compl)>Materials click Steel AISI 4340 (mat3).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Steel Base.
Next set up a structured mesh to solve the problem on.

## MESH I

In the Model Builder window, under Component I (compl) right-click Mesh I and choose Edit Physics-Induced Sequence.

Size
Disable the default free tetrahedral mesh.

## Free Tetrahedral I

I In the Model Builder window, under Component I (compI)>Mesh I right-click Free Tetrahedral I and choose Disable.

Set a maximum element size on the sensor diaphragm.
Size I
I Right-click Mesh I and choose Size.
2 In the Settings window for Size, locate the Element Size section.
3 Click the Custom button.
4 Locate the Element Size Parameters section. Select the Maximum element size check box.
5 In the associated text field, type 50 [um].
6 Locate the Geometric Entity Selection section. From the Geometric entity level list, choose Boundary.

7 Select Boundary 3 only. Create a mapped mesh on the lower surface of the device.

## Mapped I

I Right-click Mesh I and choose More Operations>Mapped.
2 Select Boundaries 3, 16, and 32 only.

3 In the Settings window for Mapped, click Build All.
Sweep the surface mesh through the structure.
Swept I
I Right-click Mesh I and choose Swept.
2 In the Settings window for Swept, click Build All.


Set up a study that sweeps over a range of applied pressures, so that the response of the sensor can be assessed.

## STUDY I

## Step I: Stationary

I In the Model Builder window, expand the Study I node, then click Step I: Stationary.
2 In the Settings window for Stationary, click to expand the Study extensions section.
3 Locate the Study Extensions section. Select the Auxiliary sweep check box.
4 Click Add.
The continuation parameter p0 (Pressure) is added by default. This is the correct parameter to sweep over.

## 5 Click Range.

6 In the Range dialog box, type 0 in the Start text field.

7 In the Step text field, type 5000.
8 In the Stop text field, type 25000.
9 Click Add.
10 On the Home toolbar, click Compute.

## RESULTS

Displacement (emi)
Much of the structure is not displaced in this initial study. To facilitate results analysis, add a selection to the solution. This will ensure that only the domains of interest are displayed in the plots.

Study I/Solution I (soll)
In the Model Builder window, expand the Results>Data Sets node, then click Study I/ Solution I (soll).

## Selection

I On the Results toolbar, click Selection.
2 In the Settings window for Selection, locate the Geometric Entity Selection section.
3 From the Geometric entity level list, choose Domain.
4 Select Domains 3 and 4 only.

## Displacement (emi)

I Click the Zoom Extents button on the Graphics toolbar.

$$
\mathrm{p} 0(6)=2.5 \mathrm{E} 4 \text { Surface: Total displacement }(\mathrm{mm})
$$



The plot now shows the displacement of the diaphragm only, which, as expected, is maximum in the center of the sensor.

Next, plot the electric potential in an $x y$-orientated plane between the sensor diaphragm and the ground plane.

## Slice I

I In the Model Builder window, expand the Potential (emi) node, then click Slice I.
2 In the Settings window for Slice, locate the Plane Data section.
3 From the Plane list, choose $\mathbf{x y}$-planes.
4 In the Planes text field, type 1.
5 Select the Interactive check box.
6 In the Shift text field, type -5.8E-6.

7 On the Potential (emi) toolbar, click Plot.
Due to the deformation of the diaphragm the potential is non-uniformly distributed in the plane.

$$
\mathrm{p} 0(6)=2.5 \mathrm{E} 4 \text { Slice: Electric potential (V) }
$$



Next, plot the deformation of the diaphragm as a function of the pressure differential across it. Include both average and maximum displacements.

## Global I

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 3 and choose Global.
Use the point integration and surface average operators defined earlier to evaluate the displacement at the mid-point of the membrane and the average displacement.

3 In the Settings window for Global, locate the y-Axis Data section.
4 In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| intop1 (w) | um | Maximum Displacement |
| aveop1 (w) | um | Average Displacement |

ID Plot Group 3
I In the Model Builder window, under Results click ID Plot Group 3.

2 In the Settings window for ID Plot Group, click to expand the Title section.
3 From the Title type list, choose Manual.
4 In the Title text area, type Diaphragm displacement.
5 Locate the Plot Settings section. Select the $\mathbf{x}$-axis label check box.
6 In the associated text field, type Pressure (Pa).
7 Select the $\mathbf{y}$-axis label check box.
8 In the associated text field, type Displacement ( $\backslash \mathrm{mu} \mathrm{m}$ ).
9 Click to expand the Legend section. From the Position list, choose Lower left.
10 Right-click Results> ID Plot Group 3 and choose Rename.
II In the Rename ID Plot Group dialog box, type Diaphragm Displacement vs Pressure in the New label text field.

I2 Click OK.
I3 On the Diaphragm Displacement vs Pressure toolbar, click Plot.


At an applied pressure of 10 kPa the diaphragm displacement in the centre is 0.89 um . The average displacement of the diaphragm is 0.27 vm . These values are in good
agreement with the approximate model given in (maximum displacement 0.93 vm , average displacement 0.27 vm ).

Now plot the sensor capacitance as a function of the applied pressure. If the switched capacitor amplifier described in is used to produce the output, the sensor output or transfer function is directly proportional to the change in capacitance.

## Global I

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 4 and choose Global.
Since the Terminal boundary condition was used for the underside of the diaphragm, COMSOL automatically computes its capacitance with respect to ground. The value of the capacitance is available as a variable in results analysis.

3 In the Settings window for Global, click Replace Expression in the upper-right corner of the $\mathbf{y}$-axis data section. From the menu, choose Component I>Electromechanics> Terminals>emi.CII - Maxwell capacitance.

Next, compare the computed capacitance with the small-displacement, linearized analytic expression derived in .

4 Locate the $\boldsymbol{y}$-Axis Data section. In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| emi.C11 | pF | Capacitance |
| $0.738[\mathrm{pF}]^{*}(1+8.87 \mathrm{e}-6[1 / \mathrm{Pa}] * \mathrm{p0})$ | pF | Linearized Analytic <br> Capacitance |

## ID Plot Group 4

I In the Model Builder window, under Results click ID Plot Group 4.
2 In the Settings window for ID Plot Group, locate the Title section.
3 From the Title type list, choose Manual.
4 In the Title text area, type Model Capacitance vs Pressure.
5 Locate the Plot Settings section. Select the $\mathbf{x}$-axis label check box.
6 In the associated text field, type Pressure (Pa).
7 Select the $\mathbf{y}$-axis label check box.
8 In the associated text field, type Capacitance ( pF ).
9 Locate the Legend section. From the Position list, choose Upper left.
10 Right-click Results> ID Plot Group 4 and choose Rename.

II In the Rename ID Plot Group dialog box, type Model Capacitance vs Pressure in the New label text field.

12 Click OK.
I3 On the Model Capacitance vs Pressure toolbar, click Plot.


The capacitance of the sensor increases with applied pressure. The gradient of the curve plotted gives a useful measure of the response of the device. At the origin, the response of the model ( $1 / 4$ of the whole sensor) is $7 \mathrm{e}-6 \mathrm{pF} / \mathrm{Pa}$, compared to the analytical response of $6.5 \mathrm{e}-6 \mathrm{pf} / \mathrm{Pa}$. The response for the whole sensor is $29 \mathrm{e}-6 \mathrm{pF} / \mathrm{Pa}$ compared to the analytic value of $26 \mathrm{e}-6 \mathrm{pF} / \mathrm{Pa}$. With the measurement circuit proposed in this corresponds to a sensor transfer function of $29 \mathrm{vV} / \mathrm{Pa}$ for the COMSOL model and 26 $\mathrm{vV} / \mathrm{Pa}$ for the simple analytic model. The response is nonlinear, so that at 20 kPa the model output is $14 \mathrm{e}-6 \mathrm{pf} / \mathrm{Pa}$ (device output $57 \mathrm{pF} / \mathrm{Pa}$ ).

Next, add thermal expansion to the model to assess the effects of packaging stresses on the device performance.

## ELECTROMECHANICS (EMI)

## Thermal Expansion I

I In the Model Builder window, under Component I (compl)>Electromechanics (emi) rightclick Linear Elastic Material I and choose Thermal Expansion.

The model temperature should be set to the previously defined room temperature parameter, $T_{0}$.

2 In the Settings window for Thermal Expansion, locate the Model Inputs section.
3 In the $T$ text field, type To.
The reference temperature indicates the temperature at which the structure had no thermal strains. In this case, set it to the previously defined parameter, Tref, which represents the temperature at which the silicon die was bonded to the metal carrier plate.

4 Locate the Thermal Expansion Properties section. In the $T_{\text {ref }}$ text field, type Tref.
The user defined properties you added previously for silicon did not include its thermal expansivity, so this must be added.

## MATERIALS

## Silicon (matl)

COMSOL shows a warning in the material properties settings to indicate a missing property.

I In the Model Builder window, under Component I (compl)>Materials click Silicon (matl).
2 In the table, add a value for the thermal expansivity of silicon to the appropriate row:
Add a new study to compute the system response including thermal expansivity effects.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies>Stationary.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

Step I: Stationary
I In the Model Builder window, under Study 2 click Step I: Stationary.

2 In the Settings window for Stationary, locate the Study Extensions section.
3 Select the Auxiliary sweep check box.
4 Click Add.
The continuation parameter po (Differential Pressure) is added by default. This is the correct parameter to sweep over.

5 Click Range.
6 In the Range dialog box, type 0 in the Start text field.
7 In the Step text field, type 5000.
8 In the Stop text field, type 25000.
9 Click Add.
10 On the Home toolbar, click Compute.

## RESULTS

Displacement (emi) I
Create a mirrored dataset to visualize a cross section of the device.
Mirror 3D I
I On the Results toolbar, click More Data Sets and choose Mirror 3D.
2 In the Settings window for Mirror 3D, locate the Data section.
3 From the Data set list, choose Study 2/Solution 2 (sol2).
Displacement (emi) I
I In the Model Builder window, under Results click Displacement (emi) I.
2 In the Settings window for 3D Plot Group, locate the Data section.
3 From the Data set list, choose Mirror 3D I.

4 On the Displacement (emi) I toolbar, click Plot.
Notice that the entire structure is now displaced at room temperature as a result of thermal expansion.
$p 0(6)=2.5 E 4$ Surface: Total displacement (mm)


Now look at the effect of the thermal stress on the response of the sensor.
Add an additional Global node to the previously defined plot. This separate node can point to a different data set, enabling a plot of the displacement of the thermally stressed device alongside the unstressed plot.

## Global 2

I In the Model Builder window, under Results>Diaphragm Displacement vs Pressure rightclick Global I and choose Duplicate.

2 In the Settings window for Global, locate the Data section.
3 From the Data set list, choose Study 2/Solution 2 (sol2).
Note that the aveop1 (w) expression has been removed from the table.

4 On the Diaphragm Displacement vs Pressure toolbar, click Plot.


The maximum displacement of the membrane is now non-zero at zero applied pressure, as a result of the packaging stress. The gradient of the displacement-pressure line has also changed.

## Model Capacitance vs Pressure

Now add the thermally stressed results to the Capacitance vs Pressure plot.

## Global 2

I In the Model Builder window, under Results right-click Model Capacitance vs Pressure and choose Global.

2 In the Settings window for Global, locate the Data section.
3 From the Data set list, choose Study 2/Solution 2 (sol2).
4 Click Replace Expression in the upper-right corner of the $\mathbf{y}$-axis data section. From the menu, choose Component I>Electromechanics>Terminals>emi.CII-Maxwell capacitance.

5 Locate the $\mathbf{y}$-Axis Data section. In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| emi.C11 | pF | Capacitance with Package Stress |

6 On the Model Capacitance vs Pressure toolbar, click Plot.
The packaging stress causes a significant change in the response of the device. At zero applied pressure the sensitivity of the COMSOL model has increased to $10 \mathrm{e}-6 \mathrm{pF} / \mathrm{Pa}$ ( $40 \mathrm{e}-6 \mathrm{pF} / \mathrm{Pa}$ for the entire device). Compare to the unstressed value of $6.5 \mathrm{e}-6 \mathrm{pf} / \mathrm{Pa}$ $(29 \mathrm{e}-6 \mathrm{pF} / \mathrm{Pa}$ for the entire device). The effect is even more pronounced at a pressure of 20 kPa , where the model that includes thermal stresses shows a pressure sensitivity of $25 \mathrm{e}-6 \mathrm{pf} / \mathrm{Pa}(100 \mathrm{pF} / \mathrm{Pa}$ for the entire device $)$, compared to the unstressed pressure sensitivity of $14.3 \mathrm{e}-6 \mathrm{pf} / \mathrm{Pa}$ (sensor output $57 \mathrm{pF} / \mathrm{Pa}$ ).


It may be possible to calibrate the device to remove the effect of the packaging strains. However, the addition of the thermal stresses to the system has created an additional issue, since the response of the sensor has now become temperature dependent - due to the temperature sensitivity of the thermal strains. This effect is assessed in the final study.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies>Stationary.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 3

## Step I: Stationary

I In the Model Builder window, under Study 3 click Step I: Stationary.
2 In the Settings window for Stationary, locate the Study Extensions section.
3 Select the Auxiliary sweep check box.
Sweep over operating temperature at constant applied pressure, to assess the temperature sensitivity of the device.

4 Click Add.
5 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| T0 |  |  |

6 Click Range.
7 In the Range dialog box, type 290 in the Start text field.
8 In the Step text field, type 5.
9 In the Stop text field, type 300.
10 Click Add.
For this study disable the default plots, as these will be very similar to those already generated by Study 2.

II In the Model Builder window, click Study 3.
12 In the Settings window for Study, locate the Study Settings section.
13 Clear the Generate default plots check box.
14 On the Home toolbar, click Compute.
Add a plot to show how the sensor response varies with temperature. The response is computed at an applied pressure set by the value of the parameter p 0 , defined as 20 kPa .

## RESULTS

ID Plot Group 7
I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.
3 From the Data set list, choose Study 3/Solution 3 (sol3).

## Global I

I Right-click ID Plot Group $\mathbf{7}$ and choose Global.
2 In the Settings window for Global, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I>Electromechanics> Terminals>emi.CII - Maxwell capacitance.

3 Locate the $\boldsymbol{y}$-Axis Data section. In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| emi.C11 | pF | Capacitance |

ID Plot Group 7
I In the Model Builder window, under Results click ID Plot Group 7.
2 In the Settings window for ID Plot Group, locate the Title section.
3 From the Title type list, choose Manual.
4 In the Title text area, type Model Capacitance vs Operating Temperature.
5 Locate the Plot Settings section. Select the $\mathbf{x}$-axis label check box.
6 In the associated text field, type Operating Temperature (K).
7 Right-click Results> ID Plot Group $\mathbf{7}$ and choose Rename.
8 In the Rename ID Plot Group dialog box, type Capacitance vs Operating Temperature in the New label text field.

9 Click OK.

IO On the Capacitance vs Operating Temperature toolbar, click Plot.


At a pressure of 20 kPa the temperature sensitivity of the model is given by the gradient of this curve, approximately $3.5 \mathrm{e}-3 \mathrm{pF} / \mathrm{K}(14 \mathrm{e}-4 \mathrm{pF} / \mathrm{K}$ for the whole device $)$. Given the pressure sensitivity of $25 \mathrm{e}-6 \mathrm{pF} / \mathrm{Pa}$ at 20 kPa this corresponds to equivalent pressure of $140 \mathrm{~Pa} / \mathrm{K}$ in the sensor output. Compared to the noise floor of the measuring circuit proposed in $(0.6 \mathrm{~Pa})$ this number is very large. This model shows that a naive choice of packaging can have a highly detrimental effect on sensor performance.

## Appendix - Geometry Instructions

From the File menu, choose New.

## NEW

In the New window, click Blank Model.

## ROOT

On the Home toolbar, click Component and choose Add Component>3D.

## GEOMETRY I

I In the Model Builder window, under Component I (compl) click Geometry I.

2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose mm.
Block I (blk I)
I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type 1.2.
4 In the Depth text field, type 1.2.
5 In the Height text field, type 1.51.
6 Locate the Position section. In the $\mathbf{z}$ text field, type -1.1.
7 Click to expand the Layers section. In the table, enter the following settings:

| Layer name | Thickness (mm) |
| :--- | :--- |
| Layer 1 | 0.7 |
| Layer 2 | 0.397 |
| Layer 3 | 0.003 |
| Layer 4 | 0.01 |

Block 2 (blk2)
I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type 0.5.
4 In the Depth text field, type 0.5.
5 In the Height text field, type 1.51.
6 Locate the Position section. In the $\mathbf{z}$ text field, type -1.1.

## Partition Domains I (pard I)

I On the Geometry toolbar, click Booleans and Partitions and choose Partition Domains.
2 On the object blkI, select Domains l-4 only.
3 In the Settings window for Partition Domains, locate the Partition Domains section.
4 From the Partition with list, choose Objects.
5 Select the object blk2 only.
Hexahedron I (hexl)
I On the Geometry toolbar, click More Primitives and choose Hexahedron.
2 In the Settings window for Hexahedron, locate the Vertices section.

3 In row 2, set $\mathbf{x}$ to 0.5 .
4 In row $\mathbf{3}$, set $\mathbf{x}$ to 0.5 .
5 In row 4, set $\mathbf{x}$ to 0 .
6 In row $\mathbf{6}$, set $\mathbf{x}$ to 0.78322 .
7 In row $\mathbf{7}$, set $\mathbf{x}$ to 0.78322 .
8 In row 8, set $\mathbf{x}$ to 0 .
9 In row $\mathbf{2}$, set $\mathbf{y}$ to 0 .
10 In row 3 , set $y$ to 0.5 .
II In row 4 , set $\mathbf{y}$ to 0.5 .
$\mathbf{1 2}$ In row 6 , set $\boldsymbol{y}$ to 0 .
13 In row 7, set y to 0.78322 .
14 In row 8, set $\mathbf{y}$ to 0.78322 .
15 In row $I$, set $\mathbf{z}$ to 0.01 .
16 In row 2 , set $\mathbf{z}$ to 0.01 .
17 In row $\mathbf{3}$, set $\mathbf{z}$ to 0.01 .
18 In row 4 , set $\mathbf{z}$ to 0.01 .
19 In row 5 , set $\mathbf{z}$ to 0.41 .
20 In row $\mathbf{6}$, set $\mathbf{z}$ to 0.41 .
21 In row 7 , set $\mathbf{z}$ to 0.41 .
$2 \mathbf{2}$ In row 8 , set $\mathbf{z}$ to 0.41 .
Difference I (difl)
I On the Geometry toolbar, click Booleans and Partitions and choose Difference.
2 Select the object pardI only.
3 In the Settings window for Difference, locate the Difference section.
4 Find the Objects to subtract subsection. Select the Active toggle button.
5 Select the object hexI only.
Cylinder I (cyll)
I On the Geometry toolbar, click Cylinder.
2 In the Settings window for Cylinder, locate the Size and Shape section.
3 In the Radius text field, type 3.
4 In the Height text field, type 0.7.

5 Locate the Position section. In the $\mathbf{z}$ text field, type -1.1.

## Partition Domains 2 (pard2)

I On the Geometry toolbar, click Booleans and Partitions and choose Partition Domains.
2 On the object cyII, select Domain I only.
3 In the Settings window for Partition Domains, locate the Partition Domains section.
4 From the Partition with list, choose Extended faces.
5 On the object difI, select Boundaries 17 and 38 only.
6 In the tree, select difI.
7 Click Build Selected.
8 On the Geometry toolbar, click Delete.

## Delete Entities I (dell)

I In the Model Builder window, under Component I (compl)>Geometry I click Delete Entities I (dell).

2 In the Settings window for Delete Entities, locate the Entities or Objects to Delete section.
3 From the Geometric entity level list, choose Domain.
4 On the object pard2, select Domains 1-3 only.
5 On the object blk2, select Domain I only.

## Form Union (fin)

I In the Model Builder window, under Component I (compl)>Geometry I click Form Union (fin).

2 In the Settings window for Form Union/Assembly, click Build Selected.

## Explicit Selection I (sell)

I On the Geometry toolbar, click Selections and choose Explicit Selection.
2 In the Settings window for Explicit Selection, type YZ Symmetry Plane in the Label text field.

3 Locate the Entities to Select section. From the Geometric entity level list, choose Boundary.

4 Select the Group by continuous tangent check box.
5 On the object fin, select Boundaries $1,4,7,10,14,17,20,23,26$, and 30 only.
Explicit Selection 2 (sel2)
I On the Geometry toolbar, click Selections and choose Explicit Selection.

2 In the Settings window for Explicit Selection, type XZ Symmetry Plane in the Label text field.

3 Locate the Entities to Select section. From the Geometric entity level list, choose Boundary.

4 Select the Group by continuous tangent check box.
5 On the object fin, select Boundaries 2, 5, 8, 11, 40, 42, 44, 46, 48, and 50 only.
Box Selection I (boxsell)
I On the Geometry toolbar, click Selections and choose Box Selection.
2 In the Settings window for Box Selection, type Steel Base in the Label text field.
3 Locate the Box Limits section. In the $\mathbf{z}$ maximum text field, type -0.1.
4 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

## Explicit Selection 3 (sel3)

I On the Geometry toolbar, click Selections and choose Explicit Selection.
2 In the Settings window for Explicit Selection, type Cavity in the Label text field.
3 On the object fin, select Domain 3 only.

## Explicit Selection 4 (sel4)

I On the Geometry toolbar, click Selections and choose Explicit Selection.
2 In the Settings window for Explicit Selection, type Geometry in the Label text field.
3 Locate the Entities to Select section. From the Geometric entity level list, choose Object.
4 Select the object fin only.
Difference Selection I (difsell)
I On the Geometry toolbar, click Selections and choose Difference Selection.
2 In the Settings window for Difference Selection, type Linear Elastic in the Label text field.

3 Locate the Input Entities section. Click Add.
4 In the Add dialog box, select Geometry in the Selections to add list.
5 Click OK.
6 In the Settings window for Difference Selection, locate the Input Entities section.
7 Click Add.
8 In the Add dialog box, select Cavity in the Selections to subtract list.
9 Click OK.

## Composite Piezoelectric Transducer

## Introduction

This example shows how to set up a piezoelectric transducer model following the work of Y. Kagawa and T. Yamabuchi (Ref. 1). The composite piezoelectric ultrasonic transducer has a cylindrical geometry that consists of a piezoceramic (NEPEC 6) layer, two aluminum layers, and two adhesive layers. The layers are organized as follows: aluminum layeradhesive layer-piezoceramic layer-adhesive layer-aluminum layer.

The system applies an AC potential on the electrode surfaces of both sides of the piezoceramic layer. The potential in this example has a peak value of 1 V in the frequency range 20 kHz to 106 kHz . The goal is to compute the susceptance (the imaginary part of the admittance) $Y=I / V$, where $I$ is the total current and $V$ is the potential, for a frequency range around the four lowest eigenfrequencies of the structure.

The first step finds the eigenmodes, and the second step runs a frequency sweep across an interval that encompasses the first four eigenfrequencies. Both analyses are fully coupled, and COMSOL Multiphysics assembles and solves both the electric and mechanical parts of the problem simultaneously.

Although you could analyze this problem using a 2D axisymmetric model, in order to illustrate the modeling principles for more complicated problems, this example uses a 3D geometry.

When creating the model geometry, you make use of the symmetry by first making a cut along a midplane perpendicular to the central axis and then by cutting out a 10 -degree wedge; doing so reduces memory requirements significantly.

## Model Data

The model uses the following material data.

## NEPEC 6 MATERIAL PARAMETERS

| 128 GPa | 68 GPa | 66 GPa | 0 | 0 | 0 |
| :---: | :---: | :---: | :---: | :---: | :---: |
|  | 128 GPa | 66 GPa | 0 | 0 | 0 |
|  |  | 110 GPa | 0 | 0 | 0 |
|  |  |  | 21 GPa | 0 | 0 |
|  |  |  |  | 21 GPa | 0 |
|  |  |  |  |  | 21 GPa |
| TABLE 2: COUPLING MATRIX $e$ |  |  |  |  |  |
| 0 | 0 | 0 | 0 | 0 | 0 |
| 0 | 0 | 0 | 0 | 0 | 0 |
| -6.1 | -6.1 | 15.7 | 0 | 0 | 0 |

TABLE 3: RELATIVE PERMITTIVITY $\varepsilon_{\mathrm{rS}}$

| 993.53 | 0 | 0 |
| :--- | :--- | :--- |
|  | 993.53 | 0 |
|  |  | 993.53 |

## ALUMINUM MATERIAL PARAMETERS

| PARAMETER | EXPRESSION/VALUE | DESCRIPTION |
| :--- | :--- | :--- |
| E | 70.3 GPa | Young's modulus |
| nu | 0.345 | Poisson's ratio |
| rho | 2690 | Density |

ADHESIVE MATERIAL PARAMETERS

| PARAMETER | EXPRESSION/VALUE | DESCRIPTION |
| :--- | :--- | :--- |
| E | 10 GPa | Young's modulus |
| nu | 0.38 | Poisson's ratio |
| rho | 1700 | Density |

## Results and Discussion

Figure 1 shows the lowest vibration mode of the piezoelectric transducer, while Figure 2 shows the transducer's input susceptance as a function of the excitation frequency.


Figure 1: The lowest vibration eigenmode of the transducer.


Figure 2: Input susceptance as a function of excitation frequency.

The result is in agreement with the work in Ref. 1. A small discrepancy close to the eigenfrequencies appears because the simulation uses no damping.

## Reference

1. Y. Kagawa and T. Yamabuchi, "Finite Element Simulation of a Composite Piezoelectric Ultrasonic Transducer," IEEE Transactions on Sonics and Ultrasonics, vol. SU-26, no. 2, pp. 81-88, 1979.

Application Library path: MEMS_Module/Piezoelectric_Devices/ composite_transducer

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Piezoelectric Devices.
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces> Eigenfrequency.

6 Click Done.

## GEOMETRY I

I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose mm.

## Plane Geometry

I On the Geometry toolbar, click Work Plane.

2 In the Model Builder window, under Component I (compl)>Geometry I> Work Plane I (wpI) click Plane Geometry.

## Circle I (cl)

I On the Work Plane toolbar, click Primitives and choose Circle.
2 In the Settings window for Circle, locate the Size and Shape section.
3 In the Radius text field, type 27.5.
4 In the Sector angle text field, type 10.
5 Right-click Circle I (cl) and choose Build Selected.
6 Click the Zoom Extents button on the Graphics toolbar.


7 In the Model Builder window, click Geometry I.
Extrude I (extl)
I On the Geometry toolbar, click Extrude.
2 In the Settings window for Extrude, locate the Distances section.
3 In the table, enter the following settings:

## Distances (mm)

5
5.275
15.275

## 4 Click Build All Objects.

## 5 Click Go to Default View.

This completes the geometry modeling stage.


Before defining material properties, select the domains where each physics applies. Proceeding in this order enables to preselect required material properties during their definition.

## SOLID MECHANICS (SOLID)

## Piezoelectric Material I

I In the Model Builder window, under Component I (compI)>Solid Mechanics (solid) click Piezoelectric Material I.

2 In the Settings window for Piezoelectric Material, locate the Domain Selection section.
3 Click Clear Selection.
4 Select Domain 1 only.

## ELECTROSTATICS (ES)

On the Physics toolbar, click Solid Mechanics (solid) and choose Electrostatics (es).
I In the Model Builder window, under Component I (compl) click Electrostatics (es).
2 In the Settings window for Electrostatics, locate the Domain Selection section.
3 Click Clear Selection.

## 4 Select Domain 1 only.

Now materials can be defined.

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, type Nepec 6 in the Label text field.
3 Locate the Geometric Entity Selection section. Click Clear Selection.
4 Select Domain 1 only.
5 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :---: | :---: | :---: | :---: | :---: |
| Elasticity matrix (Ordering: xx, yy, zz, yz, xz, xy) | \{cEII, cEI2, cE22, cEI3, cE23, cE33, cE14, cE24, cE34, cE44, cEI5, cE25, cE35, cE45, cE55, cEI6, cE26, cE36, cE46, cE56, cE66\} ; cEij = cEji | \{128[GPa], <br> 68[GPa], <br> 128 [GPa], <br> 66[GPa], <br> 66[GPa], <br> 110[GPa], <br> $0,0,0$, <br> 21[GPa], 0, <br> $0,0,0$, <br> 21[GPa], 0, <br> $0,0,0,0$, <br> 21[GPa]\} | Pa | Stress-charge form |
| Coupling matrix | \{eESII, eES2I, eES3I, eESI2, eES22, eES32, eESI3, eES23, eES33, eESI4, eES24, eES34, eESI5, eES25, eES35, eESI6, eES26, eES36\} |  | $\mathrm{C} / \mathrm{m}^{2}$ | Stress-charge form |
| Relative permittivity | epsilonrS ; epsilonrSii = epsilonrS, epsilonrSij $=0$ | 993.53 | I | Stress-charge form |
| Density | rho | 7730 | $\mathrm{kg} / \mathrm{m}^{3}$ | Basic |

Alternatively, to define the symmetric elasticity matrix, $C E$, and the full coupling matrix, eES, you can click the Edit button below the Output properties table under Component1>Materials>Nepec 6>Stress-Charge form in the Model builder and use the matrix input dialogs to enter the data as given in section .

## Material 2 (mat2)

I Right-click Materials and choose Blank Material.
2 In the Settings window for Material, type Adhesive in the Label text field.
3 Select Domain 2 only.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | $10[\mathrm{GPa}]$ | Pa | Basic |
| Poisson's ratio | nu | 0.38 | I | Basic |
| Density | rho | 1700 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |

## Material 3 (mat3)

I Right-click Materials and choose Blank Material.
2 In the Settings window for Material, type Aluminum in the Label text field.
3 Select Domain 3 only.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | $70.3[\mathrm{GPa}]$ | Pa | Basic |
| Poisson's ratio | nu | 0.345 | I | Basic |
| Density | rho | 2690 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |

SOLID MECHANICS (SOLID)
Now apply the boundary conditions for each physics.

## Symmetry I

I In the Model Builder window, under Component I (compl) right-click Solid Mechanics (solid) and choose More Constraints>Symmetry.
2 Select Boundaries 1-5, 7, and 8 only.

3 In the Settings window for Symmetry, click Go to Default View.


## ELECTROSTATICS (ES)

## Terminal I

I In the Model Builder window, under Component I (compl) right-click Electrostatics (es) and choose the boundary condition Terminal.

2 Select Boundary 6 only.
3 In the Settings window for Terminal, locate the Terminal section.
4 From the Terminal type list, choose Voltage.
5 In the $V_{0}$ text field, type 0.5.
This is half of the total peak voltage between the terminals, which accounts for modeling only the upper half of the transducer.

## Ground I

I In the Model Builder window, right-click Electrostatics (es) and choose Ground.
2 Select Boundary 3 only.

## DEFINITIONS

Before generating the mesh, define a variable for the susceptance.

## Variables I

I In the Model Builder window, under Component I (compI) right-click Definitions and choose Variables.

2 In the Settings window for Variables, locate the Variables section.
3 In the table, enter the following settings:

| Name | Expression | Unit | Description |
| :--- | :--- | :--- | :--- |
| B | imag $($ es.Y11 $) * 36 / 2$ |  | Susceptance |

In the above expression, the factor 36 compensates for the fact that the total current at the Terminal is only computed for a 10 degree wedge of the full transducer. Moreover, the factor $1 / 2$ accounts for the fact that only the upper half of the transducer is modeled because of symmetry in the $z$ direction and hence only half of the actual voltage is applied. Since no damping is modeled, the real part of the admittance es. Y11 will be zero. This is why it is suitable to evaluate only the imaginary part of the admittance, i.e. the susceptance.

## MESH I

I In the Model Builder window, under Component I (compl) click Mesh I.
2 In the Settings window for Mesh, locate the Mesh Settings section.
3 From the Element size list, choose Finer.

## Free Triangular I

I Right-click Component I (compl)>Mesh I and choose More Operations>Free Triangular.
2 Select Boundary 3 only.
Distribution I
I Right-click Component I (compI)>Mesh I>Free Triangular I and choose Distribution.
2 Select Edges 2 and 3 only.
3 In the Settings window for Distribution, locate the Distribution section.
4 From the Distribution properties list, choose Predefined distribution type.
5 In the Number of elements text field, type 20.

## 6 Click Build Selected.

## Swept I

I In the Model Builder window, right-click Mesh I and choose Swept.
2 In the Settings window for Swept, click Build All.

3 Click the Zoom Extents button on the Graphics toolbar.


## STUDY I

On the Home toolbar, click Compute.

## RESULTS

## Surface I

I In the Model Builder window, expand the Mode Shape (solid) node, then click Surface I.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>Displacement field (material and geometry frames) $>\mathbf{w}$ - Displacement field, Z component.

3 On the Mode Shape (solid) toolbar, click Plot.
Compare the resulting plot to that in .

## Multislice I

In the Model Builder window, expand the Electric Potential (es) node.

## Surface I

I Right-click Multislice I and choose Delete.
2 In the Model Builder window, under Results right-click Electric Potential (es) and choose Surface.

3 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Electrostatics>Electric>V Electric potential.
4 On the Electric Potential (es) toolbar, click Plot.
Next, add a separate study for the frequency sweep.

ADD STUDY
I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Frequency Domain.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

## Step I: Frequency Domain

I In the Model Builder window, under Study 2 click Step I: Frequency Domain.
2 In the Settings window for Frequency Domain, locate the Study Settings section.
3 Click Range.
4 In the Range dialog box, type $20[\mathrm{kHz}]$ in the Start text field.
5 In the Stop text field, type $106[\mathrm{kHz}]$.
6 In the Step text field, type $2[\mathrm{kHz}]$.
7 Click Replace.
8 On the Home toolbar, click Compute.

## RESULTS

## Multislice I

In the Model Builder window, expand the Electric Potential (es) I node.

## Electric Potential (es) I

I Right-click Multislice I and choose Delete.
2 On the Electric Potential (es) I toolbar, click Surface.

## Surface I

I In the Model Builder window, under Results>Electric Potential (es) I click Surface I.

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Electrostatics>Electric>V Electric potential.

3 On the Electric Potential (es) I toolbar, click Plot.

## 3D Plot Group 5

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Settings window for 3D Plot Group, type Displacement in the Label text field.
3 Locate the Data section. From the Data set list, choose Study 2/Solution 2 (sol2).
4 From the Parameter value (freq (Hz)) list, choose I.06E5.
5 On the Displacement toolbar, click Surface.

## Surface I

I In the Model Builder window, under Results>Displacement click Surface I.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>Displacement field (material and geometry frames) $>\mathbf{w}$ - Displacement field, Z component.

3 On the Displacement toolbar, click Plot.


## ID Plot Group 6

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, type Susceptance in the Label text field.
3 Locate the Data section. From the Data set list, choose Study 2/Solution 2 (sol2).

## Global I

I Right-click Susceptance and choose Global.
2 In the Settings window for Global, locate the $\mathbf{y}$-Axis Data section.
3 In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| B | S | Susceptance |

4 Locate the x-Axis Data section. From the Unit list, choose kHz.
5 On the Susceptance toolbar, click Plot.
Compare the result to that in .

## Electrostatically Actuated Cantilever

## Introduction

The elastic cantilever beam is an elementary structure in MEMS design. This example shows the bending of a beam due to electrostatic forces. The model uses the electromechanics interface to solve the coupled equations for the structural deformation and the electric field. Such structures are frequently tested by means of a low frequency capacitance voltage sweep. The model predicts the results of such a test.

## Model Definition

Figure 1 shows the model geometry. The beam has the following dimensions:

- Length: $300 \mu \mathrm{~m}$
- Width: $20 \mu \mathrm{~m}$
- Thickness $2 \mu \mathrm{~m}$

Because the geometry is symmetric only half of the beam needs to modeled. The beam is made of polysilicon with a Young's modulus, $E$, of 153 GPa , and a Poisson's ratio, v, of 0.23 . It is fixed at one end but is otherwise free to move. The polysilicon is assumed to be heavily doped, so that electric field penetration into the structure can be neglected. The beam resides in an air-filled chamber that is electrically insulated. The lower side of the chamber has a grounded electrode.


Figure 1: Model Geometry. The beam is $300 \mu \mathrm{~m}$ long and $2 \mu \mathrm{~m}$ thick, and it is fixed at $x=0$. The model uses symmetry on the $z x-p l a n e ~ a t ~ y=0$. The lower boundary of the surrounding air
domain represents the grounded substrate. The model has $20 \mu \mathrm{~m}$ of free air above and to the sides of the beam, while the gap below the beam is $2 \mu \mathrm{~m}$.

An electrostatic force caused by an applied potential difference between the two electrodes bends the beam toward the grounded plane beneath it. To compute the electrostatic force, this example calculates the electric field in the surrounding air. The model considers a layer of air $20 \mu \mathrm{~m}$ thick both above and to the sides of the beam, and the air gap between the bottom of the beam and the grounded layer is initially $2 \mu \mathrm{~m}$. As the beam bends, the geometry of the air gap changes continuously, resulting in a change in the electric field between the electrodes. The coupled physics is handled automatically by the Electromechanics interface.

The electrostatic field in the air and in the beam is governed by Poisson's equation:

$$
-\nabla \cdot(\varepsilon \nabla V)=0
$$

where derivatives are taken with respect to the spatial coordinates. The numerical model represents the electric potential and its derivatives on a mesh which is moving with respect to the spatial frame. The necessary transformations are taken care of by the Electromechanics interface, which also contains smoothing equations governing the movement of the mesh in the air domain.

The cantilever connects to a voltage terminal with a specified bias potential, $V_{\mathrm{in}}$. The bottom of the chamber is grounded, while all other boundaries are electrically insulated. The terminal boundary condition automatically computes the capacitance of the system.

The force density that acts on the electrode of the beam results from Maxwell's stress tensor:

$$
\mathbf{F}_{\mathrm{es}}=-\frac{1}{2}(\mathbf{E} \cdot \mathbf{D}) \mathbf{n}+(\mathbf{n} \cdot \mathbf{E}) \mathbf{D}
$$

where $\mathbf{E}$ and $\mathbf{D}$ are the electric field and electric displacement vectors, respectively, and $\mathbf{n}$ is the outward normal vector of the boundary. This force is always oriented along the normal of the boundary.

Navier's equations, which govern the deformation of a solid, are more conveniently written in a coordinate system that follows and deforms with the material. In this case, these reference or material coordinates are identical to the actual mesh coordinates.

## Results and Discussion

There is positive feedback between the electrostatic forces and the deformation of the cantilever beam. The forces bend the beam and thereby reduce the gap to the grounded substrate. This action, in turn, increases the forces. At a certain voltage the electrostatic forces overcome the stress forces, the system becomes unstable, and the gap collapses. This critical voltage is called the pull-in voltage.

At applied voltages lower than the pull-in voltage, the beam stays in an equilibrium position where the stress forces balance the electrostatic forces. Figure 2 shows the beam displacement and the corresponding displacement of the mesh surrounding it. Figure 3 shows the electric potential and electric field that generates these displacements. In Figure 4 the shape of the cantilever's deflection is illustrated for each applied voltage, by plotting the z -displacement of the underside of the beam at the symmetry boundary. The tip deflection as a function of applied voltage is shown in Figure 5. Note that for applied voltages higher than the pull-in voltage, the solution does not converge because no stable stationary solution exists. This situation occurs if an applied voltage of 6.2 V is tried. The pull-in voltage is therefore between 6.1 V and 6.2 V . For comparison, computations in Ref. 1 predict a pull-in voltage of

$$
V_{\mathrm{PI}}=\sqrt{\frac{4 c_{1} B}{\varepsilon_{0} L^{4} c_{2}^{2}\left(1+c_{3} \frac{g_{0}}{W}\right)}}
$$

where $c_{1}=0.07, c_{2}=1.00$, and $c_{3}=0.42 ; g_{0}$ is the initial gap between the beam and the ground plane; and

$$
B=\hat{E} H^{3} g_{0}^{3}
$$

If the beam has a narrow width $(W)$ relative to its thickness $(H)$ and length $(L), \hat{E}$ is Young's modulus, $E$. Otherwise, $E$ and $\hat{E}$, the plate modulus, are related by

$$
\frac{E}{\hat{E}} \approx 1-v^{2}\left(\frac{(W / L)^{1,37}}{0,5+(W / L)^{1,37}}\right)^{0,98(L / H)^{-0,056}}
$$

where $v$ is Poisson's ratio. Because the calculation in Ref. 1 uses a parallel-plate approximation for calculating the electrostatic force and because it corrects for fringing fields, these results are not directly comparable with those from the simulation. However the agreement is still reasonable: setting $W=20 \mu \mathrm{~m}$ results in $V_{\mathrm{PI}}=6.07 \mathrm{~V}$.

VO(8)=6.1 Surface: Displacement field, Z component ( $\mu \mathrm{m}$ ) Volume: $\mathbf{z - Z}$ ( $\mu \mathrm{m}$ ) Slice: $z-Z(\mu \mathrm{~m})$


Figure 2: z-displacement for the beam and the moving mesh as a function of position. Each mesh element is depicted as a separate block in the back half of the geometry.

> V0(8)=6.1 Slice: Electric potential (V) Surface: Electric potential (V) Arrow Volume: Electric field (spatial frame)


Figure 3: Electric Potential (color) and Electric Field (arrows) at various cross sections through the beam.


Figure 4: Displacement of the lower surface of the cantilever, plotted along the symmetry boundary, for different values of the applied voltage.


Figure 5: Cantilever tip displacements as a function of applied Voltage $V_{0}$.


Figure 6: Device capacitance vs applied voltage $V_{0}$.
Figure 6 shows the DC C-V curve predicted for the cantilever beam. To some extent, this is consistent with the behavior of an ideal parallel plate capacitor, whose capacitance increases with decreasing distance between the plates. But this effect does not account for all the change in capacitance observed. In fact, most of it is due to the gradual softening of the coupled electromechanical system. This effect leads to a larger structural response for a given voltage increment at higher bias, which in turn means that more charge must be added to retain the voltage difference between the electrodes.

Reference

1. R.K. Gupta, Electrostatic Pull-In Structure Design for In-Situ Mechanical Property Measurements of Microelectromechanical Systems (MEMS), Ph.D. thesis, MIT, 1997.

Application Library path: MEMS_Module/Actuators/ electrostatically_actuated_cantilever

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Electromechanics (emi).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Stationary.
6 Click Done.

## GEOMETRY I

Use microns to define the geometry units.
I In the Model Builder window, under Component I (compI) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Create the geometry so that a swept mesh can be used subsequently. Three blocks are required as to sweep the mesh no change in the $Y-Z$ cross section is allowed.

## Block I (blkI)

I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type 320.
4 In the Depth text field, type 10.
5 In the Height text field, type 2.
6 Locate the Position section. In the $\mathbf{z}$ text field, type 2.
7 Right-click Block I (blkI) and choose Build Selected.
Block 2 (blk2)
I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type 320.

4 In the Depth text field, type 40.
5 In the Height text field, type 24.
Block 3 (blk3)
I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type 300.
4 In the Depth text field, type 40.
5 In the Height text field, type 24.
6 Click Build All Objects.
Add a parameter for the DC voltage applied to the cantilever.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| V0 | $5[\mathrm{~V}]$ | 5 V | Bias on cantilever |

The cantilever is assumed to be heavily doped so that it acts as a conductor, held at constant potential. The Linear Elastic Material feature is therefore used.

## ELECTROMECHANICS (EMI)

## Linear Elastic Material I

I In the Model Builder window, under Component I (compl) right-click Electromechanics (emi) and choose Linear Elastic Material.

2 Select Domain 2 only.
Fix one end of the cantilever.

## Fixed Constraint I

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Structural>Fixed Constraint.

2 Select Boundary 4 only.
Since only half of the cantilever is included in the model, the symmetry condition should be applied on the mid-plane of the solid. The electric field default condition (Zero Charge) is equivalent to a symmetry condition, so only the structural symmetry boundary condition needs to be applied.

Symmetry I
I Right-click Electromechanics (emi) and choose the boundary condition Structural> Symmetry.

2 Select Boundary 5 only.
Use the Terminal feature to set the voltage on the exterior of the cantilever.

## Terminal I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Terminal.

2 Select Boundaries 6, 8, 10, and 15 only.
3 In the Settings window for Terminal, locate the Terminal section.
4 From the Terminal type list, choose Voltage.
5 In the $V_{0}$ text field, type Vo.
Set up the ground plane underneath the cantilever.

## Ground I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Ground.

2 Select Boundaries 3 and 14 only.
Apply boundary conditions to constrain the mesh deformation.
Prescribed Mesh Displacement 2
I Right-click Electromechanics (emi) and choose the boundary condition Deformed Mesh> Prescribed Mesh Displacement.

2 Select Boundaries $2,7,13,16,18,23$, and 24 only.
3 In the Settings window for Prescribed Mesh Displacement, locate the Prescribed Mesh Displacement section.
4 Clear the Prescribed z displacement check box.
This way, you allow the mesh nodes to move in the $z$ direction while they are fixed in the $x$ and $y$ directions.
Confirm that the default features have acquired the correct selections.

5 Click the Wireframe Rendering button on the Graphics toolbar.

## Prescribed Mesh Displacement I

The default mesh displacement feature constrains all the remaining boundaries to have zero displacement.

## Electromechanical Interface I

The Electromechanical Interface feature applies forces to the exterior boundaries of the cantilever.

## Zero Charge I

The Zero Charge feature applies symmetry conditions to the remaining boundaries where the electric potential is solved for.

Add Materials to the model.

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.
3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Relative permittivity | epsilonr | 4.5 | I | Basic |
| Young's modulus | E | $153[\mathrm{GPa}]$ | Pa | Basic |
| Poisson's ratio | nu | 0.23 | I | Basic |
| Density | rho | 2330 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |

Material 2 (mat2)
I Right-click Materials and choose Blank Material.
2 Select Domains 1, 3, and 4 only.
Set the material to be non-solid, to ensure the interface solves the electrostatics equations in the spatial frame.

3 In the Settings window for Material, click to expand the Material properties section.
4 Locate the Material Properties section. From the Material type list, choose Nonsolid.

5 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :---: | :---: | :---: | :---: | :---: |
| Relative permittivity | epsilonr | 1 | I | Basic |

Create a swept mesh.

MESH I
Mapped I
I In the Model Builder window, under Component I (comp I) right-click Mesh I and choose More Operations>Mapped.

2 Select Boundary 4 only.
Distribution I
I Right-click Component I (compI)>Mesh I>Mapped I and choose Distribution.
2 Select Edge 5 only.
Size
I In the Model Builder window, under Component I (compl)>Mesh I click Size.
2 In the Settings window for Size, locate the Element Size section.
3 From the Predefined list, choose Extremely fine.
4 Click the Custom button.
5 Locate the Element Size Parameters section. In the Maximum element size text field, type 4.

## Free Quad I

I In the Model Builder window, right-click Mesh I and choose More Operations>Free Quad.
2 Select Boundary 1 only.
3 In the Settings window for Free Quad, click Build All.
Swept I
I Right-click Mesh I and choose Swept.
2 In the Settings window for Swept, locate the Domain Selection section.
3 From the Geometric entity level list, choose Domain.
4 Select Domains 1 and 2 only.

## Distribution I

I Right-click Component I (compI)>Mesh I>Swept I and choose Distribution.
2 In the Settings window for Distribution, locate the Distribution section.
3 In the Number of elements text field, type 20.
4 Click Build AlI.

## Swept 2

I In the Model Builder window, right-click Mesh I and choose Swept.
2 In the Settings window for Swept, locate the Domain Selection section.
3 From the Geometric entity level list, choose Domain.
4 Select Domains 3 and 4 only.
Distribution I
I Right-click Component I (compl)>Mesh I>Swept 2 and choose Distribution.
2 In the Settings window for Distribution, click Build All.
Set up a Parametric Sweep over the applied voltage.

## STUDY I

Step I: Stationary
I In the Settings window for Stationary, click to expand the Study extensions section.
2 Locate the Study Extensions section. Select the Auxiliary sweep check box.
3 Click Add.
4 Click Range.
5 In the Range dialog box, type 1 in the Start text field.
6 In the Step text field, type 1.
7 In the Stop text field, type 6.
8 Click Add.
Add points at 6.05 and 6.1 V to the sweep by adding these points after the range statement. The table field should now contain: range $(1,1,6) 6.056 .1$.

9 On the Home toolbar, click Compute.

## RESULTS

Displacement (emi)
Create additional data sets for post processing. First create a mirrored data set.

## Mirror 3D I

I On the Results toolbar, click More Data Sets and choose Mirror 3D.
2 In the Settings window for Mirror 3D, locate the Plane Data section.
3 From the Plane list, choose $\mathbf{z x}$-planes.
Then create a data set with some surface selections.

## Selection

I In the Model Builder window, under Results>Data Sets right-click Study I/ Solution I (soll) and choose Duplicate.

2 On the Results toolbar, click Selection.
3 In the Settings window for Selection, locate the Geometric Entity Selection section.
4 From the Geometric entity level list, choose Boundary.
5 Select Boundaries 3-6, 8, 10, 14, and 15 only.
Finally, mirror this data set.
Mirror 3D 2
I On the Results toolbar, click More Data Sets and choose Mirror 3D.
2 In the Settings window for Mirror 3D, locate the Data section.
3 From the Data set list, choose Study I/Solution I (2) (soll).
4 Locate the Plane Data section. From the Plane list, choose zx-planes.
Edit the default displacement plot to show the $z$-displacement and the corresponding mesh deformation.

Displacement (emi)
I In the Model Builder window, under Results click Displacement (emi).
2 In the Settings window for 3D Plot Group, locate the Data section.
3 From the Data set list, choose Mirror 3D I.

## Surface I

I In the Model Builder window, expand the Displacement (emi) node, then click Surface I.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I> Electromechanics (Solid Mechanics)>Displacement>
Displacement field (material and geometry frames) $>\mathbf{w}$ - Displacement field, $\mathbf{Z}$ component.
3 Locate the Coloring and Style section. Select the Reverse color table check box.

## Volume I

I In the Model Builder window, under Results right-click Displacement (emi) and choose Volume.

2 In the Settings window for Volume, locate the Data section.
3 From the Data set list, choose Study I/Solution I (I) (soll).
4 Locate the Expression section. In the Expression text field, type z-Z.
5 Click to expand the Shrink elements section. Locate the Shrink Elements section. In the Element scale factor text field, type 0.8.
6 Click to expand the Inherit style section. Locate the Inherit Style section. From the Plot list, choose Surface I.

Slice I
I Right-click Displacement (emi) and choose Slice.
2 In the Settings window for Slice, locate the Expression section.
3 In the Expression text field, type $z-Z$.
4 Click to expand the Inherit style section. Locate the Inherit Style section. From the Plot list, choose Surface I.

5 On the Displacement (emi) toolbar, click Plot.
Edit the default potential plot.
Potential (emi)
I In the Model Builder window, under Results click Potential (emi).
2 In the Settings window for 3D Plot Group, locate the Data section.
3 From the Data set list, choose Mirror 3D I.

## Slice I

I In the Model Builder window, expand the Potential (emi) node, then click Slice I.
2 In the Settings window for Slice, locate the Plane Data section.
3 In the Planes text field, type 7.

## Surface I

I In the Model Builder window, under Results right-click Potential (emi) and choose Surface.

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I> Electromechanics (Electrical Quasistatics) $>$ Electric $>$ V - Electric potential.

3 Locate the Data section. From the Data set list, choose Mirror 3D 2.
4 Click to expand the Inherit style section. Locate the Inherit Style section. From the Plot list, choose Slice I.

## Arrow Volume I

I Right-click Potential (emi) and choose Arrow Volume.
2 In the Settings window for Arrow Volume, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I> Electromechanics (Electrical Quasistatics)>Electric>emi.Ex,...,emi.Ez Electric field (spatial frame).
3 Locate the Arrow Positioning section. Find the y grid points subsection. In the Points text field, type 15.

4 Locate the Coloring and Style section. From the Arrow length list, choose Normalized.
5 On the Potential (emi) toolbar, click Plot.
Add a plot to show the deformed shape of the underside of the cantilever.

## Line Graph I

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 3 and choose Line Graph.
3 Select Edge 6 only.
4 In the Settings window for Line Graph, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I> Electromechanics (Solid Mechanics)>Displacement>
Displacement field (material and geometry frames) $>\mathbf{w}$ - Displacement field, $\mathbf{Z}$ component.
5 Click to expand the Legends section. Select the Show legends check box.
ID Plot Group 3
I In the Model Builder window, under Results click ID Plot Group 3.
2 In the Settings window for ID Plot Group, click to expand the Legend section.
3 From the Position list, choose Lower left.
4 Click to expand the Title section. From the Title type list, choose Manual.
5 In the Title text area, type Shape of cantilever displacement for different applied voltages.
6 Right-click Results> ID Plot Group 3 and choose Rename.
7 In the Rename ID Plot Group dialog box, type Displacement vs Applied Voltage in the New label text field.

## 8 Click OK.

9 On the Displacement vs Applied Voltage toolbar, click Plot.
Add a plot of tip displacement vs applied DC voltage.

## Point Graph I

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 4 and choose Point Graph.
3 Select Point 10 only.
4 In the Settings window for Point Graph, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I>
Electromechanics (Solid Mechanics)>Displacement>
Displacement field (material and geometry frames) $>\mathbf{w}$ - Displacement field, $\mathbf{Z}$ component.

## ID Plot Group 4

I In the Model Builder window, under Results right-click ID Plot Group 4 and choose Rename.

2 In the Rename ID Plot Group dialog box, type Tip Displacement vs Applied Voltage in the New label text field.

3 Click OK.
4 On the Tip Displacement vs Applied Voltage toolbar, click Plot.
Finally, plot the DC capacitance of the device vs voltage.

## Global I

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 5 and choose Global.
3 In the Settings window for Global, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I>Electromechanics> Terminals>emi.CII - Maxwell capacitance.

Modify the automatically generated expression to account for the symmetry boundary condition.

4 Locate the $\mathbf{y}$-Axis Data section. In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| $2^{*}$ emi.C11 | fF | Capacitance |

## ID Plot Group 5

I In the Model Builder window, under Results right-click ID Plot Group 5 and choose Rename.

2 In the Rename ID Plot Group dialog box, type DC C-V Curve in the New label text field.
3 Click OK.
4 On the DC C-V Curve toolbar, click Plot.

## Gecko Foot

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## Introduction

In nature, various species apply advanced techniques for specialized tasks. For instance, gecko lizards use dry adhesion forces such as van der Waals forces to climb walls. Dry adhesion is a phenomenon of interest for sticking because it requires no energy to hold on, and no residue is left on the surface. Gecko lizards have inspired researchers to develop synthetic gecko foot hairs for use in, for example, robots.

A strand of hair on a gecko foot is a very complex biological structure with hierarchical nanosections and microsections. On its feet, a gecko has billions of nanoscale hairs that are in contact with surfaces while it climbs. These nanohairs are attached to microscale hairs, which are on the tip of the gecko's toes.

Critical design parameters for nanohairs to achieve optimal sticking are hair length, detach angle, distance between nanohairs, and the cross-sectional area of a single strand of hair. By varying these parameters, it is possible to design hairs that can stick to very rough surfaces. At the same time, they must be stiff enough to avoid sticking to each other. Proper material choices help achieving the design goals while providing the required adhesion force. Typically the Young's modulus for materials used in synthetic nanohair vary between 1 GPa and 15 GPa .

## Model Definition

This model contains the hierarchy of synthetic gecko foot hair where nanoscale and microscale cantilever beams describe the seta and spatula parts of a spatular stalk attached to a gecko foot. The basis of the analyzed structure is a microscale stalk with the following dimensions: width, $4.53 \mu \mathrm{~m}$; height, $4.33 \mu \mathrm{~m}$; and length, $75 \mu \mathrm{~m}$. At the end of the microhair, 169 nanohairs are attached and they have dimensions of $0.18 \mu \mathrm{~m}, 0.17 \mu \mathrm{~m}$, and $3 \mu \mathrm{~m}$, respectively. The microhair is fixed at the far end, while the contact and friction forces appear as surface loads at the end of each nanohair. The free-body diagram of a micro/nanohair in Figure 1 illustrates the applied forces, which are set to $0.4 \mu \mathrm{~N}$ for the contact force and $0.2 \mu \mathrm{~N}$ for the friction force with $60^{\circ}$ contact angle to target surface. The structure is made of $\beta$-keratin with a Young's modulus of 2 GPa and a Poisson's ratio of 0.4 . The model was inspired by Ref. 1 .


Figure 1: Model of the tip of a gecko foot hair.

## Results and Discussion

The plot in Figure 2 shows the von Mises effective stress in the model. Table 1 lists the maximum values of the von Mises stress, total displacement, and principal strain:

TABLE I: STRESS, DISPLACEMENT, AND PRINCIPAL STRAIN RESULTS IGNORING GEOMETRIC NONLINEARITY.

| MAXIMUM YON MISES <br> STRESS $\left(\mathrm{N} / \mathrm{m}^{2}\right)$ | MAXIMUM TOTAL <br> DISPLACEMENT $(\mu \mathrm{m})$ | MAXIMUM FIRST PRINCIPAL STRAIN |
| :--- | :--- | :--- |
| $9.52 \cdot 10^{7}$ | 12.6 | 0.0505 |

The maximum von Mises stress in the analyzed model is almost twice the value of the material's yield stress, which clearly indicates that further investigation is required.

The deformed plot in Figure 2 shows that displacement is large, while the results in the table above indicate that the maximum strain is moderate. Hence, the next step is to enable the geometric nonlinearity within the linear elastic material model. (An alternative would be to search for a suitable hyperelastic material model, which would require the corresponding material data.)


Figure 2: Deformed shape plot of the von Mises stress in a synthetic gecko foot ignoring geometric nonlinearity. The plot shows the displacements without any scaling.


Figure 3: The result recomputed with the geometric nonlinearity taken into account.

You include the geometric nonlinearity by selecting the corresponding check box in the Linear Elastic Material Model feature node. The resulting changes in the model equations are shown under the Equation section therein.

The plot in Figure 3 shows the resulting von Mises stress distribution and the deformation, and Table 2 below gives the recomputed maximum values.

TABLE 2: STRESS, DISPLACEMENT, AND PRINCIPAL STRAIN RESULTS INCLUDING GEOMETRIC NONLINEARITY EFFECTS

| MAXIMUM YON MISES <br> STRESS $\left(\mathrm{N} / \mathrm{m}^{2}\right)$ | MAXIMUM TOTAL <br> DISPLACEMENT $(\mu \mathrm{m})$ | MAXIMUM FIRST PRINCIPAL STRAIN |
| :--- | :--- | :--- |
| $1.73 \cdot 10^{7}$ | 2.93 | $8.85 \cdot 10^{-3}$ |

The results show that without the geometric nonlinearity taken into account, the model overpredicts the maximum von Mises stress by more than a factor of five, and the maximum displacement by more than a factor of four. Furthermore, the maximum strain computed with the geometric nonlinearity included becomes less than $1 \%$, which eliminates the need of further analysis involving more complicated hyperelastic material models.

## References

1. G. Shah and I. Lee, Finite Element Analysis of Gecko Foot Hairs for Dry Adhesive Design and Fabrication, Dept. of Mechanical Engineering-NanoRobotics Lab, Carnegie Mellon Univ., Pittsburgh.
2. M. Sitti and R.S. Fearing, "Synthetic Gecko Foot-Hair Micro/Nano-Structures for Future Wall-Climbing Robots," Proc. IEEE Robotics and Automation Conf., Sept. 2003.
3. J. Vincent, Structural Biomaterials, rev. ed., Princeton University Press, 1990.

Application Library path: MEMS_Module/Actuators/gecko_foot

## Modeling Instructions

From the File menu, choose New.

## NE W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Solid Mechanics (solid).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Stationary.
6 Click Done.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| Fc | $0.4[\mathrm{uN}]$ | $4 \mathrm{E}-7 \mathrm{~N}$ | Contact force |
| Ff | $0.2[\mathrm{uN}]$ | $2 \mathrm{E}-7 \mathrm{~N}$ | Friction force |
| theta | $\mathrm{pi} / 3$ | 1.047 | Contact angle |
| Dm | $75[\mathrm{um}]$ | $7.5 \mathrm{E}-5 \mathrm{~m}$ | Microhair length |
| Hm | $4.33[\mathrm{um}]$ | $4.33 \mathrm{E}-6 \mathrm{~m}$ | Microhair width |
| Wm | $4.53[\mathrm{um}]$ | $4.53 \mathrm{E}-6 \mathrm{~m}$ | Microhair height |
| Dn | $3[\mathrm{um}]$ | $3 \mathrm{E}-6 \mathrm{~m}$ | Nanohair length |
| Hn | $0.17[\mathrm{um}]$ | $1.7 \mathrm{E}-7 \mathrm{~m}$ | Nanohair width |
| Wn | $0.18[\mathrm{um}]$ | $\mathrm{I} .8 \mathrm{E}-7 \mathrm{~m}$ | Nanohair height |
| Area | Wn*Hn | $3.06 \mathrm{E}-14 \mathrm{~m}^{2}$ | Cross-sectional area of the <br> spatulae |

GEOMETRY I
I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Block I (blk I)
I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.

3 In the Width text field, type Wn.
4 In the Depth text field, type Dn.
5 In the Height text field, type Hn.
6 Locate the Position section. In the $\boldsymbol{y}$ text field, type - Dn.
7 Right-click Block I (blkI) and choose Rename.
8 In the Rename Block dialog box, type Nanohair in the New label text field.
9 Click OK.
Next, add object selections for the nanohair's root and end. An object selection is defined by a set of geometric entities at a specified level selected from the geometric objects that precede the object selection feature in the geometry sequence. Their main advantage compared to regular selection features is that object selections propagate through the geometry sequence, which make them robust and convenient to apply in cases like the present one.

Explicit Selection I (sell)
I On the Geometry toolbar, click Selections and choose Explicit Selection.
2 In the Settings window for Explicit Selection, locate the Entities to Select section.
3 From the Geometric entity level list, choose Boundary.
4 On the object blkI, select Boundary 3 only.
5 Right-click Explicit Selection I (selI) and choose Rename.
6 In the Rename Explicit Selection dialog box, type Nanohair ends in the New label text field.
The use of plural anticipates the fact that you will create an array of nanohairs; this object selection will automatically propagate to all of these.

## 7 Click $\mathbf{O K}$.

## Explicit Selection 2 (sel2)

I On the Geometry toolbar, click Selections and choose Explicit Selection.
2 Click the Wireframe Rendering button on the Graphics toolbar.
3 In the Settings window for Explicit Selection, locate the Entities to Select section.
4 From the Geometric entity level list, choose Boundary.
5 On the object blkI, select Boundary 6 only.
6 Click the Wireframe Rendering button on the Graphics toolbar.
7 Right-click Explicit Selection 2 (sel2) and choose Build Selected.

8 Right-click Explicit Selection 2 (sel2) and choose Rename.
9 In the Rename Explicit Selection dialog box, type Nanohair roots in the New label text field.

IO Click OK.
Array I (arrl)
I On the Geometry toolbar, click Transforms and choose Array.
2 Select the object blkI only.
3 In the Settings window for Array, locate the Size section.
4 In the $\mathbf{x}$ size text field, type 13 .
5 In the $\mathbf{z}$ size text field, type 13.
6 Locate the Displacement section. In the $\mathbf{x}$ text field, type (Wm-Wn)/12.
7 In the $\mathbf{z}$ text field, type $(\mathrm{Hm}-\mathrm{Hn}) / 12$.
8 Right-click Array I (arrI) and choose Build Selected.
9 Click the Zoom Extents button on the Graphics toolbar.
Block 2 (blk2)
I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type Wm.
4 In the Depth text field, type Dm.
5 In the Height text field, type Hm.
6 Right-click Block 2 (blk2) and choose Build Selected.
7 Right-click Block 2 (blk2) and choose Rename.
8 In the Rename Block dialog box, type Microhair in the New label text field.
9 Click OK.
Explicit Selection 3 (sel3)
I On the Geometry toolbar, click Selections and choose Explicit Selection.
2 In the Settings window for Explicit Selection, locate the Entities to Select section.
3 From the Geometric entity level list, choose Boundary.
4 On the object blk2, select Boundary 3 only.
5 Right-click Explicit Selection 3 (sel3) and choose Build Selected.
6 Right-click Explicit Selection 3 (sel3) and choose Rename.

8 | GECKO FOOT

7 In the Rename Explicit Selection dialog box, type Microhair end in the New label text field.

8 Click OK.
9 In the Settings window for Explicit Selection, click Go to Default View.

## Form Union (fin)

Use an assembly to connect parts of the geometry of significantly different dimensions.
I In the Model Builder window, under Component I (compI)>Geometry I click Form Union (fin).

2 In the Settings window for Form Union/Assembly, locate the Form Union/Assembly section.
3 From the Action list, choose Form an assembly.
4 Clear the Create pairs check box.
5 Right-click Component I (compI)>Geometry I>Form Union (fin) and choose Build Selected.

The model geometry is now complete.

## DEFINITIONS

Because of the use of assembly, you need to add an identity pair to set up the displacement field continuity at the interfaces, where the nanohairs are attached to the microhair. Configure the identity to operate on the material frame, because this is the frame used within the Solid Mechanics interface.

## Identity Boundary Pair I (pl)

I On the Definitions toolbar, click Pairs and choose Identity Boundary Pair.
2 In the Settings window for Pair, locate the Source Boundaries section.
3 From the Selection list, choose Microhair end.
4 Locate the Destination Boundaries section. Select the Active toggle button.
5 From the Selection list, choose Nanohair roots.
Define a rotated coordinate system to account for the contact angle.

## Rotated System 2 (sys2)

I On the Definitions toolbar, click Coordinate Systems and choose Rotated System.
2 In the Settings window for Rotated System, locate the Settings section.
3 Find the Euler angles (Z-X-Z) subsection. In the $\beta$ text field, type $\mathrm{pi} / 2$-theta.

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.
3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | 2 e 9 | Pa | Basic |
| Poisson's ratio | nu | 0.4 | I | Basic |
| Density | rho | 1200 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |

## DEFINITIONS

Set up a maximum operator to compute maximum values of the von Mises stress, total displacement, and principal strain over the entire geometry.

Maximum I (maxopl)
I On the Definitions toolbar, click Component Couplings and choose Maximum.
2 In the Settings window for Maximum, locate the Source Selection section.
3 From the Selection list, choose All domains.

## Variables I

I On the Definitions toolbar, click Local Variables.
2 In the Settings window for Variables, locate the Variables section.
3 In the table, enter the following settings:

| Name | Expression | Unit | Description |
| :--- | :--- | :--- | :--- |
| max_v_Mises | maxop1(solid.mises) | $\mathrm{N} / \mathrm{m}^{2}$ | Maximum von Mises <br> stress |
| max_disp | maxop1(solid.disp) | m | Maximum total <br> displacement |
| max_ep1 | maxop1(solid.ep1) |  | Maximum first <br> principal strain |

## SOLID MECHANICS (SOLID)

## Fixed Constraint I

I In the Model Builder window, under Component I (compl) right-click Solid Mechanics (solid) and choose Fixed Constraint.

2 Select Boundary 83 only.

## Boundary Load I

I In the Model Builder window, right-click Solid Mechanics (solid) and choose Boundary Load.

2 In the Settings window for Boundary Load, locate the Boundary Selection section.
3 From the Selection list, choose Nanohair ends.
4 Locate the Coordinate System Selection section. From the Coordinate system list, choose Rotated System 2 (sys2).

5 Locate the Force section. Specify the $\mathbf{F}_{\mathrm{A}}$ vector as

| 0 | $x 1$ |
| :--- | :--- |
| -Fc/Area | $x 2$ |
| Ff/Area | $x 3$ |

## Continuity I

I Right-click Solid Mechanics (solid) and choose Pairs>Continuity.
2 In the Settings window for Continuity, locate the Pair Selection section.
3 In the Pairs list, select Identity Boundary Pair I (pI).

## MESH I

Mapped I
I In the Model Builder window, under Component I (comp I) right-click Mesh I and choose More Operations>Mapped.

2 In the Settings window for Mapped, locate the Boundary Selection section.
3 From the Selection list, choose Nanohair ends.
Size 1
I Right-click Component I (compl)>Mesh I>Mapped I and choose Size.
2 In the Settings window for Size, locate the Element Size section.
3 Click the Custom button.
4 Locate the Element Size Parameters section. Select the Maximum element size check box.

5 In the associated text field, type 0.1.

## Mapped I

I In the Model Builder window, under Component I (compl)>Mesh I click Mapped I.
2 In the Settings window for Mapped, click Build Selected.
Swept I
I In the Model Builder window, right-click Mesh I and choose Swept.
2 In the Settings window for Swept, locate the Domain Selection section.
3 From the Geometric entity level list, choose Domain.
4 From the Selection list, choose All domains.
5 Remove Domain 14 from the selection.
6 Right-click Component I (compI)>Mesh I>Swept I and choose Distribution.
7 In the Settings window for Swept, click Build Selected.

## Mapped 2

I In the Model Builder window, right-click Mesh I and choose More Operations>Mapped.
2 Select Boundary 83 only.
Distribution I
I Right-click Component I (compI)>Mesh I>Mapped 2 and choose Distribution.
2 Select Edges 162-164 and 168 only.

## Mapped 2

I In the Model Builder window, under Component I (compl)>Mesh I click Mapped 2.
2 In the Settings window for Mapped, click Build Selected.
Distribution I
I In the Model Builder window, right-click Mesh I and choose Swept.
2 Right-click Swept 2 and choose Distribution.
3 In the Settings window for Distribution, click Build Selected.
The mesh is now complete.

## STUDY I

On the Home toolbar, click Compute.

## RESULTS

## Stress (solid)

Reproduce the plot in by following these steps:
I In the Model Builder window, expand the Stress (solid) node.

## Deformation

I In the Model Builder window, expand the Results>Stress (solid) $>$ Surface I node, then click Deformation.

2 In the Settings window for Deformation, locate the Scale section.
3 Select the Scale factor check box.
4 In the associated text field, type 1.
5 On the Stress (solid) toolbar, click Plot.
6 Click the Zoom Extents button on the Graphics toolbar.
Compare the resulting plot to that in .

## Derived Values

Next, calculate the maximum values for von Mises stress, total displacement, and first principal strain; compare the results to those shown in .

## Global Evaluation I

I On the Results toolbar, click Global Evaluation.
2 In the Settings window for Global Evaluation, click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Component I>Definitions> Variables>max_v_Mises - Maximum von Mises stress.

3 Click Evaluate.

## Global Evaluation 2

I On the Results toolbar, click Global Evaluation.
2 In the Settings window for Global Evaluation, click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Component I >Definitions> Variables>max_disp - Maximum total displacement.

3 Click Table I - Global Evaluation I (max_v_Mises).

## Global Evaluation 3

I On the Results toolbar, click Global Evaluation.

2 In the Settings window for Global Evaluation, click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Component I>Definitions> Variables>max_epl - Maximum first principal strain.

3 Click Table I - Global Evaluation I (max_v_Mises).

## SOLID MECHANICS (SOLID)

## Linear Elastic Material I

Now, switch on geometric nonlinearity.

## STUDY I

Step I: Stationary
I In the Model Builder window, under Study I click Step I: Stationary.
2 In the Settings window for Stationary, locate the Study Settings section.
3 Select the Include geometric nonlinearity check box.
4 On the Home toolbar, click Compute.

## RESULTS

## Stress (solid)

Compare the plot in the Graphics window with that in .

## Global Evaluation I

Finally, compute the new maximum values and display them in a new table. Compare the results to those in .

I In the Model Builder window, under Results>Derived Values click Global Evaluation I.
2 In the Settings window for Global Evaluation, click New Table.
Global Evaluation 2
I In the Model Builder window, under Results>Derived Values click Global Evaluation 2.
2 In the Settings window for Global Evaluation, click Table 2Global Evaluation I (max_v_Mises).

## Global Evaluation 3

I In the Model Builder window, under Results>Derived Values click Global Evaluation 3.
2 In the Settings window for Global Evaluation, click Table 2-
Global Evaluation I (max_v_Mises).

## Thermal Stresses in a Layered Plate

## Introduction

This example contains an analysis of the thermal stress in a layered plate. The plate consists of three layers: the coating, the substrate, and the carrier. The coating is deposited on the substrate at a temperature of $800^{\circ} \mathrm{C}$. At this temperature both the coating and the substrate are stress-free. The temperature of the plate is then lowered to $150^{\circ} \mathrm{C}$, which induces thermal stresses in the coating/substrate assembly. At this temperature the coating/substrate assembly is epoxied to a carrier plate so that the coating/substrate has initial stresses when it is bonded to the carrier. Finally, the temperature is lowered to $20^{\circ} \mathrm{C}$.

## Model Definition

The plate is restrained from moving in the $z$ direction. This makes it possible to use the plane strain approximation in the 2D Solid Mechanics interface with. The assumption is then that the $z$-component of the strain is zero.

This model contains only thermal loads, which are introduced into the constitutive equations according to the following equations:

$$
\sigma=D \varepsilon_{\mathrm{el}}+\sigma_{0}=D\left(\varepsilon-\varepsilon_{\mathrm{th}}-\varepsilon_{0}\right)+\sigma_{0}
$$

and

$$
\varepsilon_{\mathrm{th}}=\left[\begin{array}{c}
\varepsilon_{x} \\
\varepsilon_{y} \\
\varepsilon_{z} \\
\gamma_{x y} \\
\gamma_{y z} \\
\gamma_{x z}
\end{array}\right]_{\mathrm{th}}=\alpha_{\mathrm{vec}}\left(T-T_{\mathrm{ref}}\right)
$$

where $\sigma$ is the stress vector, $D$ is the elasticity matrix, $\varepsilon_{x}, \varepsilon_{y}, \varepsilon_{z}, \gamma_{x y}, \gamma_{y z}, \gamma_{x z}$ are the strain components, $\alpha_{v e c}$ is the coefficient of thermal expansion, $T$ is the actual temperature, and $T_{\text {ref }}$ is the reference temperature.

The geometry of the plate is shown in Figure ???. The top layer in the geometry is the coating, the middle layer is the substrate, and the bottom layer is the carrier.


Figure 1: The plate geometry.
The analysis uses two steps:

## STEP I

In the first step you lower the temperature from $800^{\circ} \mathrm{C}$ to $150^{\circ} \mathrm{C}$, which affects the coating layer and the substrate layer. The carrier layer is not active in this step.

In both steps the upper-left corner of the coating is fixed, and the upper-right corner of the coating is constrained in the $y$ direction. This prevents rigid-body movements but does not affect the stress distribution.

## STEP 2

In this step all three layers are active and you drop the temperature from $150{ }^{\circ} \mathrm{C}$ to room temperature, $20^{\circ} \mathrm{C}$. This step includes the initial stresses from Step 1.

## Results and Discussion

Figure ?!? depicts the normal stress in the $x$ direction from the first analysis step. The substrate material has a higher coefficient of thermal expansion than the coating material. This means that the substrate shrinks more than the coating, causing tensile stresses in the substrate area next to the coating and compressive stresses in the coating.


Figure 2: Normal stress in the $x$ direction for the first analysis step.
Figure ?!? shows the residual thermal $x$-stress in the final step where the temperature is lowered to $20^{\circ} \mathrm{C}$. The tensile stress levels have increased somewhat in the substrate area next to the coating, as have the compressive stress in the coating compared to the first process step. The main stress contribution is clearly the added initial stress from the first process step.


Figure 3: Residual thermal stress at room temperature.

Application Library path: MEMS_Module/Actuators/layered_plate

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D.
2 In the Select Physics tree, select Structural Mechanics>Solid Mechanics (solid).
Add two different solid interfaces, one for the structure before adding the carrier, and one for the complete structure.

3 Click Add.
4 In the Select Physics tree, select Structural Mechanics>Solid Mechanics (solid).
5 Click Add.
6 Click Study.
7 In the Select Study tree, select Preset Studies for Selected Physics Interfaces>Stationary.
8 Click Done.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value |
| :--- | :--- | :--- |
| Ttop | $800[\mathrm{degC}]$ | 1073 K |

GEOMETRY I
Rectangle I (rl)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Height text field, type 0.002.
4 In the Width text field, type 0.02.
5 Click Build All Objects.
Rectangle 2 (r2)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 0.02.
4 In the Height text field, type 0.01.
5 Locate the Position section. In the $y$ text field, type 0.002.
6 Click Build All Objects.

## Rectangle 3 (r3)

I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 0.02.
4 In the Height text field, type 0.002.
5 Locate the Position section. In the $\boldsymbol{y}$ text field, type 0.012.
6 Click Build All Objects.
7 Click the Zoom Extents button on the Graphics toolbar.

## SOLID MECHANICS (SOLID)

I In the Model Builder window, under Component I (compl) click Solid Mechanics (solid).
2 In the Settings window for Solid Mechanics, type Two Layers in the Label text field.
3 Select Domains 2 and 3 only.

TWO LAYERS (SOLID)
On the Physics toolbar, click Solid Mechanics (solid) and choose Two Layers (solid).

## Linear Elastic Material I

In the Model Builder window, expand the Component I (comp I)>Two Layers (solid) node.

## Thermal Expansion I

I Right-click Linear Elastic Material I and choose Thermal Expansion.
2 In the Settings window for Thermal Expansion, locate the Thermal Expansion Properties section.

3 In the $T_{\text {ref }}$ text field, type Ttop.
4 Locate the Model Input section. In the $T$ text field, type Tbot.

## Rigid Motion Suppression I

I In the Model Builder window, right-click Two Layers (solid) and choose Domain Constraints>Rigid Motion Suppression.

2 In the Settings window for Rigid Motion Suppression, locate the Domain Selection section.
3 From the Selection list, choose All domains.

SOLID MECHANICS 2 (SOLID2)
I In the Model Builder window, under Component I (compl) click Solid Mechanics 2 (solid2).

2 In the Settings window for Solid Mechanics, type Three Layers in the Label text field.

## THREE LAYERS (SOLID2)

On the Physics toolbar, click Solid Mechanics 2 (solid2) and choose Three Layers (solid2).

## Thermal Expansion I

I In the Model Builder window, under Component I (compl)>Three Layers (solid2) rightclick Linear Elastic Material I and choose Thermal Expansion.

2 In the Settings window for Thermal Expansion, locate the Thermal Expansion Properties section.

3 In the $T_{\text {ref }}$ text field, type Tbot.
4 Locate the Model Input section. In the $T$ text field, type Troom.

## Rigid Motion Suppression I

I In the Model Builder window, right-click Three Layers (solid2) and choose Domain Constraints>Rigid Motion Suppression.

2 In the Settings window for Rigid Motion Suppression, locate the Domain Selection section.
3 From the Selection list, choose All domains.

## Linear Elastic Material I

Use the stresses from the two layer model as initial stresses for the three layer model.

## Initial Stress and Strain I

I In the Model Builder window, under Component I (compl)>Three Layers (solid2) rightclick Linear Elastic Material I and choose Initial Stress and Strain.

2 Select Domains 2 and 3 only.
3 In the Settings window for Initial Stress and Strain, locate the Initial Stress and Strain section.

4 In the $S_{0}$ table, enter the following settings:

| solid.sx | solid.sxy | 0 |
| :--- | :--- | :--- |
| solid.sxy | solid.sy | 0 |
| 0 | 0 | solid.sz |

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compI) right-click Materials and choose Blank Material.

2 In the Settings window for Material, type Carrier in the Label text field.

3 Locate the Geometric Entity Selection section. From the Selection list, choose Manual.
4 Click Clear Selection.
5 Select Domain 1 only.
6 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | 2.15 e 11 | Pa | Basic |
| Poisson's ratio | nu | 0.3 | I | Basic |
| Density | rho | 1000 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |
| Coefficient of thermal expansion | alpha | $6 \mathrm{e}-6$ | $\mathrm{I} / \mathrm{K}$ | Basic |

Material 2 (mat2)
I Right-click Materials and choose Blank Material.
2 In the Settings window for Material, type Substrate in the Label text field.
3 Select Domain 2 only.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | 1.3 e 11 | Pa | Basic |
| Poisson's ratio | nu | 0.28 | I | Basic |
| Density | rho | 1000 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |
| Coefficient of thermal expansion | alpha | $3 \mathrm{e}-6$ | $\mathrm{I} / \mathrm{K}$ | Basic |

Material 3 (mat3)
I Right-click Materials and choose Blank Material.
2 In the Settings window for Material, type Coating in the Label text field.
3 Select Domain 3 only.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | 7 e 10 | Pa | Basic |
| Poisson's ratio | nu | 0.17 | I | Basic |


| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Density | rho | 1000 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |
| Coefficient of thermal expansion | alpha | $5 \mathrm{e}-7$ | $\mathrm{I} / \mathrm{K}$ | Basic |

## MESH I

Size
I In the Model Builder window, under Component I (compl) right-click Mesh I and choose Mapped.

2 In the Settings window for Size, locate the Element Size section.
3 From the Predefined list, choose Extra fine.
4 Click Build AII.

## STUDY I

Add a static solution for the case with three layers.

## Step 2: Stationary 2

I On the Study toolbar, click Study Steps and choose Stationary>Stationary.
Use only one Solid Mechanics interface per solution by deactivating the other one.

## Step I: Stationary

I In the Model Builder window, under Study I click Step I: Stationary.
2 In the Settings window for Stationary, locate the Physics and Variables Selection section.
3 In the table, clear the Solve for check box for Three Layers.

## Step 2: Stationary 2

I In the Model Builder window, under Study I click Step 2: Stationary 2.
2 In the Settings window for Stationary, locate the Physics and Variables Selection section.
3 In the table, clear the Solve for check box for Two Layers.
4 On the Study toolbar, click Compute.

## RESULTS

## Surface I

I In the Model Builder window, expand the Stress (solid) node, then click Surface I.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Two Layers>Stress> Stress tensor (spatial frame)>solid.sx - Stress tensor, $\mathbf{x}$ component.

3 On the Stress (solid) toolbar, click Plot.
4 Click the Zoom Extents button on the Graphics toolbar.

## Surface I

I In the Model Builder window, expand the Results>Stress (solid2) node, then click Surface I.

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Three Layers>Stress> Stress tensor (spatial frame)>solid2.sx - Stress tensor, $x$ component.

3 On the Stress (solid2) toolbar, click Plot.

## Micropump Mechanism

1. This model is courtesy of Matthew J. Hancock and Stuart Brown of Veryst Engineering, LLC.

Micropumps are key components of microfluidic systems with applications ranging from biological fluid handling to microelectronic cooling. This model simulates the mechanism of a valveless micropump, that is designed to be effective at low Reynolds numbers, overcoming hydrodynamic reversibility. Valveless pumps are often preferred in microfludic systems because they minimize the risk of clogging and are gentle on biological material. The Fluid-Structure Interaction interface is used to solve for the flow of the fluid and the associated deformation of the structure. In addition the Global ODEs and DAEs interface is used to demonstrate how to perform a time resolved integration of the total flow throughout the pumping cycle.

## Introduction

Many valveless pump designs are ineffective when the system has a low Reynolds number, and consequently are unsuitable for viscous fluids and applications with small length scales or low flow rates. This is largely because without valves it is difficult to achieve sustained flow in a given direction.

The mechanism simulated in this model overcomes this limitation by converting oscillatory fluid motion, induced by a simple reciprocating pumping mechanism, into a net flow in one direction. It is relatively easy to create an oscillatory pumping mechanism in a microfluidic system, e.g. a membrane can be vibrated by a piezo oscillator to periodically vary the volume of a microchamber. In this model, an oscillatory flow is fed into a channel containing bendable microflaps. The deformation of the microflaps in response to the motion of the fluid alters the flow and results in a net flow rate in a consistent direction. The passive nature of the flow regulator allows for directional control of the flow without the use of the complicated synchronized actuation mechanisms that would be required in a valve based system.

In this model the Fluid-Stricture Interaction interface is used to specify the input oscillatory flow, along with the mechanical properties of the flaps. In addition, some best practice guidelines for ensuring good mesh deformation in moving-mesh problems are introduced. The deformation of the flaps, and the flow of the fluid, is calculated as a function of time for two full cycles of the pumping mechanism. This allows the physical mechanism responsible for generating the unidirectional flow to be visualized clearly using an animation. As well as visualizing flow rate and direction as a function of time throughout the pumping cycle, integration coupling components are used in conjunction with the Global ODEs and DAEs interface to calculate the net volumed pumped from left-to-right as a function of time. This is an example of how the functionality of one COMSOL interface can be enhanced by using a custom equation specified in a
mathematics interface, and demonstrates the ease with which user defined equations can be incorporated into COMSOL models.

## Model Definition

The model geometry is shown in Figure 1. It consists of a horizontal channel that is $600 \mu \mathrm{~m}$ in length and $100 \mu \mathrm{~m}$ high. A vertical chamber connects to the channel at the midpoint along its length. Two tilted flaps are attached to the bottom of the channel such that they partially obstruct flow along the channel length. The are spaced to be centered on the midpoint of the channel length, and they are both angled at 45 degrees to the to the horizontal channel edge. Note that this 2D model represents a cross-section through the midpoint of the channel in the out-of-plane direction. An out-of-plane thickness of $10 \mu \mathrm{~m}$ has been used for the purpose of calculating the volume of fluid pumped as a function of time. However, as no edge effects due to walls that are out-of-plane are included, this is equivalent to modeling a $10 \mu \mathrm{~m}$ deep section of a much thicker channel.

Note the vertical lines that connect the apex of the tilted flaps to the top of the channel. These are included as guidelines to aid the meshing algorithm as the structure deforms. Point Integration coupling components are applied to the apex of each bendable flap. These are then used to compute the horizontal displacement of the flap apex by calculating the position of the apex relative to the undeformed geometry. This is achieved by evaluating the expression ( $\mathrm{x}-\mathrm{X}$ ) using the point Integration coupling components, where $x$ and $x$ are the $x$-coordinate of the apex point in the undeformed and deformed geometry, respectively. Thus, $(x-X)$ gives the horizontal shift experienced by the vertical guidelines. Prescribed Mesh Displacement features are applied to the guidelines to force the $x$ displacement of the mesh along the guidelines to be equal to that of the flap apexes. This helps the moving mesh, which is automatically recalculated as the structure deforms, to maintain a reasonable structure around the bending flaps. In general, it is good practice to take measures like this to ensure that the mesh deforms in an appropriate way.


Figure 1: The model geometry consists of a horizontal channel and a vertical chamber. Tilted flaps are positioned within the channel, the response of these flaps to the oscillatory fluid motion induced via the labeled boundary results in a net flow from left-to-right.

The physics required for the model is configured within the Fluid-Structure Interaction interface. The Linear Elastic Material feature is applied to the two tilted flaps, and then the Fluid-Solid Interface Boundary feature is automatically assigned to the boundaries between the flaps and the fluid in the channel. An Inlet boundary feature is applied to the top of the vertical chamber. This specifies the inflow velocity, via a user input expression, to vary sinusoidally in time with a period of 1 s . An Outlet boundary feature is applied to the left and right boundaries of the channel. Two boundary integration coupling components, named intopL() and intopR() for the left and right outlets respectively, are also applied to these outlet boundaries. These are used to compute the flow rate out of each outlet. This is achieved using some user defined variables in the Definitions node within Component l. The flow rate from each outlet is calculated by integrating the depended variable u_fluid, which is the horizontal component of the fluid velocity, and multiplying by the out-of-plane length scale of $10 \mu \mathrm{~m}$. The net flow rate out of the channel, UoutNet, is then calculated from the difference between the flow from the left and right outlets, such that positive values correspond to a net flow in the left-to-right direction.

A Global ODEs and DAEs interface is added to compute the integrated net flow as a function of time. This is achieved using a Global Equation which integrates UoutNet with respect to time to obtain Vpump. This step is necessary as UoutNet gives the instantaneous net flow rate as a function in time, however a more useful metric for evaluating a pump is the total volume pumped throughout an entire pumping cycle. Note that the timeint () operator can also be used to visualize the time integration of a variable. However, use of timeint () is not as accurate as directly solving for an integrated quantitiy, as the timeint () operator only uses the timesteps which are saved in the solution but solving directly uses every timestep taken by the solver.

The mesh is configured to be tightest around the tilted flaps, in order to resolve the stress within the bending flaps. The mesh is shown in Figure 2.


Figure 2: Initial mesh prior to any structural deformation.
A single time dependent study is performed over a duration of 2 seconds, which corresponds to two full oscillations of the inlet velocity. Some minor amendments to the default solver sequence, described in the step-by-step instructions, are required to ensure reliable results. In particular, the Time Stepping is set to Strict with the maximum step set to 0.01 s . This is needed because the feedback between the flap deformation and the fluid flow can lead to abrupt changes in the flow. The default time stepping setting allows the solver to vary the time step it takes so that larger steps can be taken during times when the solution is not rapidly varying. However, because of the potential for sudden changes
to the fluid flow in fluid-structure interaction models it can be helpful to impose a maximum time step to ensure that rapid changes are not missed.

It should be noted that the geometry is parameterized so that the channel dimensions and flap angle can be straightforwardly modified by amending the relevant entry in the Global Parameters table. The average flow rate at the inlet and the fluid properties are also parameterized in the same way. In addition, the effective Reynolds number can be easily changed as the viscosity and average inlet velocity are appropriately scaled by a shared coefficient (the parameter coeff) that is computed from the target Reynolds number (the parameter Re). Note that the parameter Re_check is provided to confirm that the Reynolds number does indeed take the specified value. The model is setup with a Reynolds number of 16 , but it is straightforward to verify that the pumping action occurs even for Reynolds numbers significantly less than one.

## Results and Discussion

The mechanism by which the flow direction is regulated can be observed in the Flow and Stress default plot group. During the downstroke, when fluid is pushed from the vertical chamber into the channel, the right-hand flap is bent down towards the bottom of the channel whilst the left-hand flap is bend away from the channel bottom. This configuration is shown in Figure 3, which shows the solution at a time of 0.26 s which corresponds to when the velocity flowing into the vertical chamber via the inlet is at its maximum. Due to the asymmetric bending of the flaps, fluid can more easily flow out of the right-hand outlet. During the upstroke, when fluid is drawn from the channel into the vertical chamber, the flaps are bent in the opposite directions. This configuration is shown in Figure 4 , which shows the solution at a time of 0.74 s . Now the right hand flap restricts the flow more than the left-hand flap, and the majority of the fluid that is drawn into the vertical chamber is from the left-hand outlet.

The result of this behavior is that there is a net flow rate from left-to-right inside the channel. This has many possible applications in microfluidic systems. For example, this device could be used to deliver fluid from a droplet reservoir connected to the left-hand outlet into a microfluidic pathway connected to the right-hand outlet. Alternately, this device could be used to create a circulating system where a fluid is pumped around a continuous loop to cool a microelectronic system.


Figure 3: Velocity magnitude and velocity field, along with the von Mises stress within the flaps, during the pumping downstroke.

Time $=0.76 \mathrm{~s}$ Surface: von Mises stress ( $\mathrm{N} / \mathrm{m}^{2}$ ) Surface: Velocity magnitude ( $\mathrm{m} / \mathrm{s}$ ) Arrow Surface: Velocity field (Spatial)


Figure 4: Velocity magnitude and velocity field, along with von Mises stress within the flaps, during the pumping upstroke.

The net volume of fluid that is pumped from left-to-right is shown in Figure 5. As expected, the gradient of the curve, which is the net flow rate, varies sinusoidally with a period equal to the inlet velocity. The maximum gradients occur at intervals of odd multiples of 0.5 s , which correspond with the peaks in the magnitude of the inlet velocity.


Figure 5: Net volume pumped from left-to-right as a function of time.

Application Library path: MEMS_Module/Fluid-Structure_Interaction/ micropump_mechanism

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D.
2 In the Select Physics tree, select Fluid Flow>Fluid-Structure Interaction (fsi).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Time Dependent.
6 Click Done.
Add some parameters which will be used to control the fluid properties and device geometry.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.

3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :---: | :---: | :---: | :---: |
| Re | 16 | 16 | Reynolds number |
| coeff | 4/sqrt (Re) | I | Coefficient to change Reynolds number |
| dens | 1000[kg/m^3] | $1000 \mathrm{~kg} / \mathrm{m}^{3}$ | Fluid density |
| visc | $0.001[\mathrm{Pa*s}] * \mathrm{coeff}$ | 0.001 Pa.s | Fluid dynamic viscosity |
| U | $16[\mathrm{~cm} / \mathrm{s}$ ]/coeff | $0.16 \mathrm{~m} / \mathrm{s}$ | Average inlet flow speed |
| H | 100 [ um] | IE-4 m | Channel height |
| W | 10[um] | IE-5 m | Domain width |
| rp | 2[um] | 2E-6 m | Pillar radius |
| hp | 70 [um] | 7E-5 m | Pillar height |
| L | 600[ um] | 6E-4 m | Length of channel |
| beta | 45 [ deg] | 0.7854 rad | Flap tilt angle |
| x0 | 150[ um] | 1.5E-4 m | Flap center location |
| Re_check | dens*U*H/(visc) | 16 | Reynolds number |

Next create the geometry for the device. Notice how vertical lines are used to connect the tip of each rod to the top of the channel. This is not needed to create the desired geometry, however these lines are very helpful for limiting the deformation of the mesh elements as the rods bend. It is good practice to include boundaries to guide the deformation of a moving mesh.

## GEOMETRY I

I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.

## Rectangle I (rl)

I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type L.
4 In the Height text field, type $H$.

5 Locate the Position section. In the $\mathbf{x}$ text field, type $-\mathrm{L} / 2$.
Rectangle 2 (r2)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type $2^{*} r p$.
4 In the Height text field, type 2*hp.
5 Locate the Position section. From the Base list, choose Center.
6 In the $\mathbf{x}$ text field, type $\times 0-h p * \sin ($ beta) $/ 2$.
7 Locate the Rotation Angle section. In the Rotation text field, type - beta.

## Copy I (copyl)

I On the Geometry toolbar, click Transforms and choose Copy.
2 Select the object $\mathbf{r}$ only.
Intersection I (intl)
I On the Geometry toolbar, click Booleans and Partitions and choose Intersection.
2 Select the objects $\mathbf{r l}$ and $\mathbf{r} \mathbf{2}$ only.
3 In the Settings window for Intersection, locate the Intersection section.
4 Clear the Keep interior boundaries check box.
Fillet I (fill)
I On the Geometry toolbar, click Fillet.
2 On the object intI, select Points 3 and 4 only.
3 In the Settings window for Fillet, locate the Radius section.
4 In the Radius text field, type rp.
Bézier Polygon I (bl)
I On the Geometry toolbar, click Primitives and choose Bézier Polygon.
2 In the Settings window for Bézier Polygon, locate the Polygon Segments section.
3 Find the Added segments subsection. Click Add Linear.
4 Find the Control points subsection. In row I, set $\mathbf{x}$ to $\times 0+h \boldsymbol{p}^{*} \sin (b e t a) / 2$ and $\mathbf{y}$ to $h p *$ cos(beta).
5 In row 2 , set $\mathbf{x}$ to $x 0+h p * \sin ($ beta) $/ 2$ and $\boldsymbol{y}$ to $H$.
Copy 2 (copy2)
I On the Geometry toolbar, click Transforms and choose Copy.

2 Select the objects bl and fill only.
3 In the Settings window for Copy, locate the Displacement section.
4 In the $\mathbf{x}$ text field, type $-2 * x 0$.
Rectangle 3 (r3)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type $0.8 * \mathrm{H}$.
4 In the Height text field, type H.
5 Locate the Position section. In the $\mathbf{x}$ text field, type $-0.4^{*} \mathrm{H}$.
6 In the $y$ text field, type $H$.

## 7 Click Build All Objects.

Add two Integration Component Coupling operators, one to the boundary which forms the left outlet and one to the boundary which forms the right outlet. These operators will be used to calculate the flow rate out of each outlet.

## DEFINITIONS

## Integration I (intopl)

I On the Definitions toolbar, click Component Couplings and choose Integration.
2 In the Settings window for Integration, type intopL in the Operator name text field.
3 Locate the Source Selection section. From the Geometric entity level list, choose Boundary.

4 Select Boundary 1 only.
Integration 2 (intop2)
I On the Definitions toolbar, click Component Couplings and choose Integration.
2 In the Settings window for Integration, type intopR in the Operator name text field.
3 Locate the Source Selection section. From the Geometric entity level list, choose Boundary.

4 Select Boundary 21 only.
Add two more Integration Component Coupling operators. These integration operators are used to calculate the change in position of the tip of the rods as they bend, so that this information can be used to help control the mesh as it adapts to the changing geometry. These will be used when setting the prescribed mesh displacement settings in
the Fluid-Structure Interaction physics interface. In general, it is good practice to set up guide boundaries to help control how the mesh deforms. This model includes such boundaries as an example.

## Integration 3 (intop3)

I On the Definitions toolbar, click Component Couplings and choose Integration.
2 In the Settings window for Integration, locate the Source Selection section.
3 From the Geometric entity level list, choose Point.

## 4 Click Paste Selection.

5 In the Paste Selection dialog box, type 7 in the Selection text field.

## 6 Click OK.

## Integration 4 (intop4)

I On the Definitions toolbar, click Component Couplings and choose Integration.
2 In the Settings window for Integration, locate the Source Selection section.
3 From the Geometric entity level list, choose Point.

## 4 Click Paste Selection.

5 In the Paste Selection dialog box, type 17 in the Selection text field.

## 6 Click OK.

Create some variables to calculate the net flow rate in the channel. The first two variables calculate the average flow rate out of each outlet by performing an average over $u_{-}$fluid, which is the horizontal component of the fluid flow. Note the sign convention, that assigns positive values to left-right flow and negative values to rightleft flow. The third variable calculates the difference between the average flow rate out of each outlet, positive values correspond to a net flow from left to right.

## Variables I

I In the Model Builder window, right-click Definitions and choose Variables.
2 In the Settings window for Variables, locate the Variables section.

3 In the table, enter the following settings:

| Name | Expression | Unit | Description |
| :---: | :---: | :---: | :---: |
| UoutL | - intopL(u_fluid) *W | $\mathrm{m}^{3} / \mathrm{s}$ | Flow rate from left outlet |
| UoutR | intopR(u_fluid)*W | $\mathrm{m}^{3} / \mathrm{s}$ | Flow rate from right outlet |
| UoutNet | UoutR-UoutL | $\mathrm{m}^{3} / \mathrm{s}$ | Net flow rate |

In order to integrate the average net flow rate over time to calculate the volume of fluid that is pumped, add a Global ODE and DAEs physics interface to the model.

## ADD PHYSICS

I On the Home toolbar, click Add Physics to open the Add Physics window.
2 Go to the Add Physics window.
3 In the tree, select Mathematics>ODE and DAE Interfaces>Global ODEs and DAEs (ge).
4 Click Add to Component in the window toolbar.

GLOBAL ODES AND DAES (GE)
On the Home toolbar, click Add Physics to close the Add Physics window.

## Global Equations I

I In the Model Builder window, under Component I (compl)>Global ODEs and DAEs (ge) click Global Equations I.

2 In the Settings window for Global Equations, locate the Global Equations section.
3 In the table, enter the following settings:

| Name | f(u,ut,utt,t) (I) | Initial value <br> $\mathbf{( u \_ 0 ) ( 1 )}$ | Initial value <br> $\left(\mathbf{u} \_\mathbf{t 0}\right)(\mathbf{1 / s )}$ | Description |
| :--- | :--- | :--- | :--- | :--- |
| Vpump | Vpumpt-UoutNet | 0 | 0 | Net volume pumped <br> left-to-right |

4 Locate the Units section. Find the Dependent variable quantity subsection. From the list, choose None.

5 In the Unit text field, type $\mathrm{m}^{\wedge} 3$.
6 Find the Source term quantity subsection. From the list, choose None.
7 In the Unit text field, type $\mathrm{m}^{\wedge} 3 / \mathrm{s}$.
Configure the Fluid-Structure Interaction physics interface.

## FLUID-STRUCTURE INTERACTION (FSI)

On the Physics toolbar, click Global ODEs and DAEs (ge) and choose FluidStructure Interaction (fsi).

I In the Model Builder window, under Component I (compl) click FluidStructure Interaction (fsi).

2 In the Settings window for Fluid-Structure Interaction, locate the Free Deformation Settings section.
3 From the Mesh smoothing type list, choose Yeoh.
4 Locate the Physical Model section. From the Compressibility list, choose Incompressible flow.

## Linear Elastic Material I

I In the Model Builder window, under Component I (compl)>FluidStructure Interaction (fsi) click Linear Elastic Material I.

2 Select Domains 2 and 5 only.
3 In the Settings window for Linear Elastic Material, locate the Linear Elastic Material section.

4 Select the Nearly incompressible material check box.

## Inlet I

I In the Model Builder window, right-click Fluid-Structure Interaction (fsi) and choose the boundary condition Laminar Flow>Inlet.
2 Select Boundary 12 only.
3 In the Settings window for Inlet, locate the Velocity section.
4 In the $U_{0}$ text field, type $U^{*} 6^{*} s^{*}(1-s) * \sin \left(2 * \mathrm{pi}^{*} \mathrm{t} /(1[\mathrm{~s}])\right)$.

## Outlet I

I Right-click Fluid-Structure Interaction (fsi) and choose the boundary condition Laminar Flow>Outlet.

2 Select Boundaries 1 and 21 only.
3 In the Settings window for Outlet, locate the Pressure Conditions section.
4 Clear the Suppress backflow check box.

## Fixed Constraint I

I Right-click Fluid-Structure Interaction (fsi) and choose the boundary condition Solid Mechanics>Fixed Constraint.

2 Select Boundaries 4 and 15 only.

## Prescribed Mesh Displacement 2

I Right-click Fluid-Structure Interaction (fsi) and choose Prescribed Mesh Displacement.
2 Select Boundaries 3, 9, 14, and 20 only.
3 In the Settings window for Prescribed Mesh Displacement, locate the Prescribed Mesh Displacement section.

4 Clear the Prescribed $\mathbf{x}$ displacement check box.

## Prescribed Mesh Displacement 3

I Right-click Fluid-Structure Interaction (fsi) and choose Prescribed Mesh Displacement.
2 Select Boundary 8 only.
3 In the Settings window for Prescribed Mesh Displacement, locate the Prescribed Mesh Displacement section.

4 Clear the Prescribed y displacement check box.
5 In the $d_{x}$ text field, type intop3 $(x-X)$.

## Prescribed Mesh Displacement 4

I Right-click Fluid-Structure Interaction (fsi) and choose Prescribed Mesh Displacement.
2 Select Boundary 19 only.
3 In the Settings window for Prescribed Mesh Displacement, locate the Prescribed Mesh Displacement section.

4 Clear the Prescribed y displacement check box.
5 In the $d_{x}$ text field, type intop4 $(x-X)$.

## Prescribed Deformation I

I Right-click Fluid-Structure Interaction (fsi) and choose Prescribed Deformation.
2 Select Domain 4 only.

## Prescribed Mesh Displacement 5

I Right-click Fluid-Structure Interaction (fsi) and choose Prescribed Mesh Displacement.
2 Select Boundary 11 only.
With the physics interfaces configured, add materials to the geometry domains. In this case, it was beneficial to wait until all the physics settings were configured before adding materials, as COMSOL automatically adjusts which materials properties are needed depending on the physics assigned to each domain.

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, type Fluid in the Label text field.
3 Select Domains 1, 3, 4, and 6 only.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- | :--- |
| Density | rho | dens | $\mathrm{kg} / \mathrm{m}^{3}$ | Basic |
| Dynamic viscosity | mu | visc | $\mathrm{Pa} \cdot \mathrm{s}$ | Basic |

## Material 2 (mat2)

I Right-click Materials and choose Blank Material.
2 In the Settings window for Material, type Solid in the Label text field.
3 Select Domains 2 and 5 only.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | 3.6 e 5 | Pa | Basic |
| Poisson's ratio | nu | 0.499 | I | Basic |
| Density | rho | 970 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |

Configure the mesh.

## MESH I

## Free Triangular I

I In the Model Builder window, under Component I (compl) right-click Mesh I and choose Free Triangular.

2 In the Settings window for Free Triangular, locate the Domain Selection section.
3 From the Geometric entity level list, choose Entire geometry.

## Size

I In the Model Builder window, under Component I (compl)>Mesh I click Size.
2 In the Settings window for Size, locate the Element Size section.
3 Click the Custom button.

4 Locate the Element Size Parameters section. In the Maximum element size text field, type 10.

5 In the Minimum element size text field, type 1.4.
6 In the Maximum element growth rate text field, type 1.4.
7 In the Curvature factor text field, type 0.6.
8 In the Resolution of narrow regions text field, type 0.7.
Size 1
I In the Model Builder window, right-click Mesh I and choose Size.
2 Right-click Size I and choose Move Up.
3 In the Settings window for Size, locate the Geometric Entity Selection section.
4 From the Geometric entity level list, choose Domain.
5 Select Domains 2 and 5 only.
6 Locate the Element Size section. Click the Custom button.
7 Locate the Element Size Parameters section. Select the Maximum element size check box.
8 In the associated text field, type 2.
9 Select the Minimum element size check box.
10 In the associated text field, type 1.5.
II In the Model Builder window, click Mesh I.
I2 In the Settings window for Mesh, click Build All.
I3 Click the Zoom Extents button on the Graphics toolbar.
Configure the study, some minor changes to the default solver configuration are needed.

## STUDY I

Solution I (soll)
I On the Study toolbar, click Show Default Solver.
Set the time steps and range for the study. Also tighten the time-dependent solver tolerance to make the time steps more conservative.

## Solution I (soll)

I In the Settings window for Time Dependent, locate the Study Settings section.
2 In the Times text field, type range $(0,0.02,2)$.
3 From the Tolerance list, choose User controlled.

4 In the Relative tolerance text field, type 0.001.
Alter the time stepping in the Time-Dependent Solver I node. By default, the timedependent solver varies the time step automatically as it solves. However, for FSI simulations it is often useful to constrain this by setting a maximum step size. This improves accuracy by ensuring that abrupt changes in flow are not missed.

5 In the Model Builder window, expand the Study I>Solver Configurations>Solution I (soll) node, then click Time-Dependent Solver I.

6 In the Settings window for Time-Dependent Solver, click to expand the Time stepping section.

7 Locate the Time Stepping section. From the Steps taken by solver list, choose Intermediate.

8 Select the Maximum step check box.
9 In the associated text field, type 0.005 .
The Fully Coupled solver is often most appropriate for FSI simulations. A Fully Coupled node can be added to the Time-Dependent Solver I sequence, when this is done the default Segregated solver is overridden.

IO In the Model Builder window, expand the Study I>Solver Configurations>
Solution I (soll)>Time-Dependent Solver I node.
II Right-click Study I>Solver Configurations>Solution I (solI)>Time-Dependent Solver I and choose Fully Coupled.

I2 In the Settings window for Fully Coupled, click to expand the Method and termination section.

13 Locate the Method and Termination section. In the Maximum number of iterations text field, type 6.

14 From the Jacobian update list, choose Once per time step.
Now the study can be solved.
I5 On the Study toolbar, click Compute.
The default Flow and Stress plot group shows a color map of the von Mises stress within the flexible rods, as well as the velocity magnitude of the fluid within the channel. An Arrow Surface plot is of the fluid velocity is superimposed over the colormap. An animation of the data series allows the action of the pump to be visualized.

## RESULTS

## Animation I

I On the Results toolbar, click Animation and choose File.
2 In the Settings window for Animation, locate the Target section.
3 From the Target list, choose Player.
4 Locate the Frames section. From the Frame selection list, choose All.

## 5 Right-click Animation I and choose Play.

The animation demonstrates how the passive motion of the rods as they react to the fluid results in a net flow of fluid from left-to-right. During the "downstoke", when fluid flows from the inlet down into the channel, the right rod bends towards the bottom of the channel whilst the left rod bend away from the bottom. This restricts the flow towards the left-hand outlet, relative to the right-hand outlet. During the "upstroke", where fluid flows from the channel up towards the inlet, the rods bend in the opposite directions. Now the inward flow from the right-hand outlet towards the center of the channel is restricted. This results in a net flow from left-to-right, where fluid is drawn in from the left-hand outlet and pushed out of the right-hand outlet.

The 1D plot group, which plots Vpump from the Global ODEs and DAEs interface, confirms that there is indeed a net flow from left-to-right as expected.

## ID Plot Group 3

## I In the Model Builder window, under Results click ID Plot Group 3.

2 In the Settings window for ID Plot Group, type Net volume pumped left-to-right in the Label text field.

3 Click to expand the Legend section. From the Position list, choose Upper left.

## Microresistor Beam

## Introduction

This example illustrates the ability to couple thermal, electrical, and structural analysis in one model. This particular application moves a beam by passing a current through it; the current generates heat, and the temperature increase leads to displacement through thermal expansion. The model estimates how much current and increase in temperature are necessary to displace the beam.

Although the model involves a rather simple 3D geometry and straightforward physics, it provides a good example of multiphysics modeling.

## Model Definition



Figure 1: Microbeam geometry.
A copper microbeam has a length of $13 \mu \mathrm{~m}$ with a height and width of $1 \mu \mathrm{~m}$. Feet at both ends bond it rigidly to a substrate. An electric potential of 0.2 V applied between the feet induces an electric current. Due to the material's resistivity, the current heats up the structure. Because the beam operates in the open, the generated heat dissipates into the air. The thermally induced stress loads the material and deforms the beam.

As a first approximation, you can assume that the electrical conductivity is constant. However, a conductor's resistivity increases with temperature. In the case of copper, the
relationship between resistivity and temperature is approximately linear over a wide range of temperatures:

$$
\begin{equation*}
\rho=\rho_{0}\left(1+\alpha\left(T-T_{0}\right)\right) \tag{1}
\end{equation*}
$$

$\alpha$ is the temperature coefficient. You obtain the conductor's temperature dependency from the relationship that defines electric resistivity; conductivity is simply its reciprocal ( $\sigma$ $=1 / \rho)$.

For the heat transfer equations, set the base boundaries facing the substrate to a constant temperature of 323 K . You model the convective air cooling in other boundaries using a heat flux boundary condition with a heat transfer coefficient, $h$, of $5 \mathrm{~W} /\left(\mathrm{m}^{2} \cdot \mathrm{~K}\right)$ and an external temperature, $T_{\mathrm{inf}}$, of 298 K . Standard constraints handle the bases' rigid connection to the substrate.

## Results and Discussion

Figure 2 shows the temperature field on the microbeam surface when solving the model using a temperature-dependent resistivity as in Equation l. Based on the color scale, the maximum temperature is about 710 K .

Figure 3 shows the microbeam's deformation. The displacement for the temperaturedependent case is 48 nm compared to the maximum displacement for constant electrical conductivity, which is 88 nm (the plot scales the deformation by a factor of around 20 ).

## Surface: Temperature (K)



Figure 2: Surface temperature with temperature-dependent electrical conductivity.
Surface: Total displacement (nm)


Figure 3: Microbeam deformation with temperature-dependent electrical conductivity.

## Notes About the COMSOL Implementation

In this example you create the 3D geometry by starting with two 2D work planes. The first one views the geometry from above, and the second does so from the side. You create cross sections on the work planes, which you then extrude into 3D. As the final step you create the resistor beam geometry as the intersection of the extruded objects. You can also skip the step-by-step instructions for the geometry creation and import the ready-made geometry directly from the Application Libraries.

By using the Joule Heating and Thermal Expansion predefined multiphysics interface you automatically add the equations for three physics including the necessary multiphysics couplings. In this case the physics equations describe the current and heat conduction and structural mechanics problems. The interface also provides suitable defaults for the solver.

Application Library path: MEMS_Module/Actuators/microresistor_beam

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.

## 2 In the Select Physics tree, select Structural Mechanics> Joule Heating and Thermal Expansion.

3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces>Stationary.
6 Click Done.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.

3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| V0 | $0.2[\mathrm{~V}]$ | 0.2 V | Applied voltage |
| T0 | $323[\mathrm{~K}]$ | 323 K | Heat sink temperature |
| Text | $298[\mathrm{~K}]$ | 298 K | External temperature |
| k | $5\left[\mathrm{~W} /\left(\mathrm{m}^{\wedge} 2^{*} \mathrm{~K}\right)\right]$ | $5 \mathrm{~W} /\left(\mathrm{m}^{2} \cdot \mathrm{~K}\right)$ | Heat transfer coefficient |

GEOMETRY I
I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Work Plane I (wp I)
I On the Geometry toolbar, click Work Plane.
2 In the Settings window for Work Plane, click Show Work Plane.
Bézier Polygon I (bl)
I On the Work Plane toolbar, click Primitives and choose Bézier Polygon.
2 In the Settings window for Bézier Polygon, locate the Polygon Segments section.
3 Find the Added segments subsection. Click Add Linear.
4 Find the Control points subsection. In row 2, set xw to 5 and yw to 1.5 .
5 Find the Added segments subsection. Click Add Linear.
6 Find the Control points subsection. In row $\mathbf{2}$, set $\mathbf{x w}$ to 18.
7 Find the Added segments subsection. Click Add Linear.
8 Find the Control points subsection. In row 2, set $\mathbf{x w}$ to 23 and $\mathbf{y w}$ to 0.
9 Find the Added segments subsection. Click Add Linear.
10 Find the Control points subsection. In row 2, set yw to 4.
II Find the Added segments subsection. Click Add Linear.
I2 Find the Control points subsection. In row 2, set $\mathbf{x w}$ to 18 and $\mathbf{y w}$ to 2.5.
$\mathbf{1 3}$ Find the Added segments subsection. Click Add Linear.
14 Find the Control points subsection. In row 2, set xw to 5.
15 Find the Added segments subsection. Click Add Linear.
16 Find the Control points subsection. In row 2, set $\mathbf{x w}$ to 0 and $\mathbf{y w}$ to 4 .

17 Find the Added segments subsection. Click Add Linear.
18 Find the Control points subsection. Click Close Curve.
19 On the Work Plane toolbar, click Build All.
20 Click the Zoom Extents button on the Graphics toolbar.


Work Plane I (wpl)
In the Model Builder window, under Component I (comp I)>Geometry I click Work Plane I (wpl).

Extrude I (extl)
I On the Geometry toolbar, click Extrude.
2 In the Settings window for Extrude, locate the Distances section.
3 In the table, enter the following settings:

## Distances ( $\mu \mathrm{m}$ )

3

4 Click Build All Objects.

5 Click the Zoom Extents button on the Graphics toolbar.


## Work Plane 2 (wp2)

I On the Geometry toolbar, click Work Plane.
2 In the Settings window for Work Plane, locate the Plane Definition section.
3 From the Plane type list, choose Face parallel.
4 Find the Planar face subsection. Select the Active toggle button.
5 On the object extI, select Boundary 6 only.
6 In the Offset in normal direction text field, type -1.5.
7 Select the Reverse normal direction check box.

## 8 Click Show Work Plane.

## Plane Geometry

I In the Settings window for Plane Geometry, locate the Visualization section.
2 Find the In-plane visualization of 3D geometry subsection. Clear the Intersection (cyan) check box.

3 Clear the Coincident entities (blue) check box.
Bézier Polygon I (bl)
I On the Work Plane toolbar, click Primitives and choose Bézier Polygon.
2 In the Settings window for Bézier Polygon, locate the Polygon Segments section.

3 Find the Added segments subsection. Click Add Linear.
4 Find the Control points subsection. In row $\mathbf{I}$, set $\mathbf{x w}$ to -11.5 and $\mathbf{y w}$ to -1.5 .
5 In row $\mathbf{2}$, set $\mathbf{x w}$ to -6.3 and $\mathbf{y w}$ to -1.5 .
6 Find the Added segments subsection. Click Add Linear.
7 Find the Control points subsection. In row 2, set yw to 0.5.
8 Find the Added segments subsection. Click Add Linear.
9 Find the Control points subsection. In row 2, set xw to 6.3.
10 Find the Added segments subsection. Click Add Linear.
II Find the Control points subsection. In row 2, set yw to -1.5.
12 Find the Added segments subsection. Click Add Linear.
I3 Find the Control points subsection. In row 2, set xw to 11.5.
14 Find the Added segments subsection. Click Add Linear.
15 Find the Control points subsection. In row 2, set $\mathbf{x w}$ to 6.5 and $\mathbf{y w}$ to 1.5.
16 Find the Added segments subsection. Click Add Linear.
$\mathbf{1 7}$ Find the Control points subsection. In row 2, set $\mathbf{x w}$ to -6.5.
18 Find the Added segments subsection. Click Add Linear.
19 Find the Control points subsection. Click Close Curve.
20 Click the Zoom Extents button on the Graphics toolbar.

## Fillet I (fill)

I On the Work Plane toolbar, click Fillet.
2 On the object bl, select Points 4 and 6 only.
3 In the Settings window for Fillet, locate the Radius section.
4 In the Radius text field, type 0.3.

5 On the Work Plane toolbar, click Build All.


Work Plane 2 (wp2)
In the Model Builder window, under Component I (compl)>Geometry I click Work Plane 2 (wp2).

Extrude 2 (ext2)
I On the Geometry toolbar, click Extrude.
2 In the Settings window for Extrude, locate the Distances section.
3 In the table, enter the following settings:

Distances ( $\mu \mathrm{m}$ )
4

4 Click Build All Objects.


## Intersection I (int l)

I On the Geometry toolbar, click Booleans and Partitions and choose Intersection.
2 Click in the Graphics window and then press Ctrl+A to select both objects.
3 In the Settings window for Intersection, click Build All Objects.

## Form Union (fin)

I In the Model Builder window, under Component I (compl)>Geometry I right-click Form Union (fin) and choose Build Selected.

The model geometry is now complete.

## DEFINITIONS

Add a set of selections that you can use later when applying boundary conditions.

## Explicit I

I On the Definitions toolbar, click Explicit.
2 In the Model Builder window, right-click Explicit I and choose Rename.
3 In the Rename Explicit dialog box, type connector1 in the New label text field.
4 Click OK.
5 In the Settings window for Explicit, locate the Input Entities section.
6 From the Geometric entity level list, choose Boundary.

7 Select Boundary l only.

## Explicit 2

I On the Definitions toolbar, click Explicit.
2 In the Model Builder window, right-click Explicit 2 and choose Rename.
3 In the Rename Explicit dialog box, type connector2 in the New label text field.
4 Click OK.
5 In the Settings window for Explicit, locate the Input Entities section.
6 From the Geometric entity level list, choose Boundary.
7 Select Boundary 13 only.

## Explicit 3

I On the Definitions toolbar, click Explicit.
2 In the Model Builder window, right-click Explicit 3 and choose Rename.
3 In the Rename Explicit dialog box, type connectors in the New label text field.
4 Click OK.
5 In the Settings window for Explicit, locate the Input Entities section.
6 From the Geometric entity level list, choose Boundary.
7 Select Boundaries 1 and 13 only.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select MEMS $>$ Metals $>$ Cu - Copper.
4 Click Add to Component in the window toolbar.
5 On the Home toolbar, click Add Material to close the Add Material window.

## MATERIALS

Cu - Copper (matl)
I In the Model Builder window, under Component I (compI)>Materials click Cu Copper (matl).

2 In the Settings window for Material, locate the Material Contents section.

3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Relative permittivity | epsilonr | 1 | I | Basic |

4 Click to expand the Material properties section. Locate the Material Properties section. In the Material properties tree, select Electromagnetic Models>Linearized Resistivity> Reference resistivity (rho0).

5 Click Add to Material.
6 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- |
| Reference resistivity | rho0 | $1.72 \mathrm{e}-8[\mathrm{ohm} * \mathrm{~m}]$ | $\Omega \cdot \mathrm{m}$ | Linearized resistivity |
| Resistivity temperature <br> coefficient | alpha | $0.0039[1 / \mathrm{K}]$ | $\mathrm{I} / \mathrm{K}$ | Linearized resistivity |
| Reference temperature | Tref | $293[\mathrm{~K}]$ | K | Linearized resistivity |

## ELECTRIC CURRENTS (EC)

## Current Conservation I

I In the Model Builder window, under Component I (compI)>Electric Currents (ec) click Current Conservation I.

2 In the Settings window for Current Conservation, locate the Conduction Current section.
3 From the $\sigma$ list, choose Linearized resistivity.
Before solving the two-way coupled model with a temperature-dependent resistivity, use a constant resistivity for later comparison:

4 From the $\alpha$ list, choose User defined. Keep the default zero value for $\alpha$.

## Ground I

I In the Model Builder window, right-click Electric Currents (ec) and choose Ground.
2 In the Settings window for Ground, locate the Boundary Selection section.
3 From the Selection list, choose connector2.

## Electric Potential I

I Right-click Electric Currents (ec) and choose Electric Potential.
2 In the Settings window for Electric Potential, locate the Electric Potential section.
3 In the $V_{0}$ text field, type $V 0$.

4 Locate the Boundary Selection section. From the Selection list, choose connector I.

## MULTIPHYSICS

I In the Model Builder window, under Component I (compl)>Multiphysics click Thermal Expansion I (tel).

2 In the Settings window for Thermal Expansion, locate the Thermal Expansion Properties section.

3 In the $T_{\text {ref }}$ text field, type Text.

## HEAT TRANSFER IN SOLIDS (HT)

On the Physics toolbar, click Electric Currents (ec) and choose Heat Transfer in Solids (ht).

## Initial Values I

I In the Model Builder window, under Component I (compl)>Heat Transfer in Solids (ht) click Initial Values I.

2 In the Settings window for Initial Values, type TO in the $T$ text field.

## Heat Flux I

I In the Model Builder window, right-click Heat Transfer in Solids (ht) and choose Heat Flux.

2 In the Settings window for Heat Flux, locate the Boundary Selection section.
3 From the Selection list, choose All boundaries.
Select all boundaries for simplicity; next you will add a node that overrides this boundary condition for the connectors.

4 Locate the Heat Flux section. Click the Convective heat flux button.
5 In the $h$ text field, type k .
6 In the $T_{\text {ext }}$ text field, type Text.

## Temperature I

I Right-click Heat Transfer in Solids (ht) and choose Temperature.
2 In the Settings window for Temperature, locate the Temperature section.
3 In the $T_{0}$ text field, type TO.
4 Locate the Boundary Selection section. From the Selection list, choose connectors.

## SOLID MECHANICS (SOLID)

## Fixed Constraint I

I In the Model Builder window, under Component I (compl) right-click Solid Mechanics (solid) and choose Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.
3 From the Selection list, choose connectors.

MESH I

Size
I In the Model Builder window, under Component I (comp I) right-click Mesh I and choose Free Tetrahedral.

2 In the Settings window for Size, locate the Element Size section.
3 From the Predefined list, choose Finer.
4 In the Model Builder window, click Mesh I.
5 In the Settings window for Mesh, click Build All.

## STUDY I

You can use the default solver settings for this model.
I On the Home toolbar, click Compute.

## RESULTS

Stress (solid)
The first default plot presents a surface plot of the von Mises stress. Modify it to show the displacement magnitude.

I In the Model Builder window, right-click Stress (solid) and choose Rename.
2 In the Rename 3D Plot Group dialog box, type Displacement - Study 1 in the New label text field.

3 Click OK.

## Surface I

I In the Model Builder window, expand the Results>Displacement - Study I node, then click Surface I.

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>solid.disp - Total displacement.

3 Locate the Expression section. From the Unit list, choose nm.
4 On the Displacement - Study I toolbar, click Plot.
As the color legend shows, the maximum displacement is roughly 88 nm with a constant resistivity.


## Temperature (ht)

The second default surface plot shows the temperature field. Note the maximum temperature of roughly 1048 K .

Surface: Temperature (K)


Now restore the temperature-dependence of the resistivity that you temporarily disabled and then add a new study and solve the model again.

## ELECTRIC CURRENTS (EC)

On the Physics toolbar, click Solid Mechanics (solid) and choose Electric Currents (ec).

## Current Conservation I

I In the Model Builder window, under Component I (compl)>Electric Currents (ec) click Current Conservation I.

2 In the Settings window for Current Conservation, locate the Conduction Current section.
3 From the $\alpha$ list, choose From material.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies>Stationary.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

Step I: Stationary
On the Home toolbar, click Compute.

## RESULTS

## Temperature (ht) I

As you can see from the plot, using the more realistic material model with a temperaturedependent resistivity has a significant effect on the solution. The maximum temperature is now almost 340 K lower.

## Stress (solid)

I In the Model Builder window, under Results right-click Stress (solid) and choose Rename.
2 In the Rename 3D Plot Group dialog box, type Displacement - Study 2 in the New label text field.

3 Click OK.

## Surface I

I In the Model Builder window, expand the Results>Displacement - Study 2 node, then click Surface 1 .

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>solid.disp - Total displacement.

3 Locate the Expression section. From the Unit list, choose nm.
4 On the Displacement - Study 2 toolbar, click Plot.
Similarly, the maximum displacement has been reduced from 88 nm to around 50 nm .

## Piezoceramic Tube

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## Introduction

This example involves a static 2D axisymmetric analysis of a piezoelectric actuator using the Piezoelectric Devices multiphysics interface. It models a radially polarized piezoelectric tube, as described by S. Peelamedu and co-authors (Ref. 1). An application area where radially polarized tubes are employed is in nozzles for fluid control in inkjet printers.

## Model Definition

## GEOMETRY

The tube has a height of 0.62 mm and an inner and outer radius of 0.38 mm and 0.62 mm , respectively. It is represented in an axisymmetric geometry by a single off-axis rectangle, as shown in Figure 1.


Figure 1: The axisymmetric geometry. Length units on $x$ - and $y$-axes are shown in $\mu m$.

## BOUNDARY CONDITIONS

The model studies two cases distinguished by different boundary conditions. Case 1 represents the direct piezoelectric effect, and Case 2 represents the inverse piezoelectric effect.

Case 1—Direct Piezoelectric Effect:

- Structural mechanics boundary condition-constrain the bottom surface from moving axially (in the $z$ direction), but also add an internal fluid pressure of 0.1 MPa .
- Electrostatics boundary condition-ground the inner and outer surfaces.

Case 2—Inverse Piezoelectric Effect:

- Structural mechanics boundary condition-constrain the bottom surface from moving axially (in the $z$-direction).
- Electrostatics boundary condition-apply a l V potential difference between the tube's inner and outer surfaces.


## MATERIAL ORIENTATION

COMSOL's material library data is entered in a form which assumes that the crystal polarization is aligned with the global co-ordinate $z$ axis. For the radially polarized case treated in this model, the orientation must be rotated so that the material polarization direction is aligned with the $r$ direction (radially polarized). To do so, specify the coordinate system in the Piezoelectric Material feature. By selecting the co-ordinate system as the predefined $z x$-plane system, you rotate the material so that its $z$ direction is aligned with the $r$ direction of the model, and the material's $x$ direction is aligned with the model's $z$ direction.

The piezoceramic material in this example (PZT-5H) is a transversely isotropic material, which is a special class of orthotropic materials. Such a material has the same properties in one plane (isotropic behavior) and different properties in the direction normal to this plane. Thus you can use either the $z x$-plane material orientation or the $z y$-plane material orientation; both give the same solution.

## Results and Discussion

Figure 2 shows the radial displacement due to the applied pressure in Case 1, and Figure 3 shows the corresponding induced electric potential. Both the radial displacement and potential are shown along a cut line $300 \mu \mathrm{~m}$ above the base of the tube in Figure 4 and Figure 5, receptively.

Surface: Displacement field, R component ( $\mu \mathrm{m}$ )


Figure 2: Deformed shape and radial displacement due to an internal pressure of 0.1 MPa (case 1 -the direct piezoelectric effect).

Surface: Electric potential (V)


Figure 3: Induced electric potential within the deformed tube due to an internal pressure of 0.1 MPa (case 1 -the direct piezoelectric effect).


Figure 4: Radial displacement as a function of $r$-coordinate at a height of $300 \mu \mathrm{~m}$ above the base of the tube. The results are for Case 1—the direct piezoelectric effect.


Figure 5: Electric potential as a function of r-coordinate at a beight of $300 \mu \mathrm{~m}$ above the base of the tube. The results are for Case 1-the direct piezoelectric effect.


Figure 6: Deformed shape and radial displacement of the piezoceramic-tube actuator due to the radial electric field (Case 2-Inverse Piezoelectric Effect).


Figure 7: Electric potential applied to the tube to induce the displacements shown in Figure 6 (Case 2-Inverse Piezoelectric Effect).


Figure 8: Radial displacement as a function of $r$-coordinate at a height of $300 \mu \mathrm{~m}$ above the base of the tube. The results are for Case 2-the inverse piezoelectric effect.


Figure 9: Electric potential as a function of r-coordinate at a beight of $300 \mu \mathrm{~m}$ above the base of the tube. The results are for Case 2-the inverse piezoelectric effect.

Figure 6 shows the radial displacement resulting from the applied potential shown in Figure 7. The radial displacement and potential are shown along a cut line $300 \mu \mathrm{~m}$ above the base of the tube in Figure 8 and Figure 9, respectively.

These results show good agreement with those from S. Peelamedu (Ref. 1).

## Reference

1. S.M. Peelamedu, C.B. Kosaraju, R.V. Dukkipati and N.G. Naganathan, "Numerical Approach for Axisymmetric Piezoceramic Geometries towards Fluid Control Applications, "Proceedings of the Institution of Mechanical Engineers, Part I: J. Systems and Control Engineering, vol. 214, no. 2, pp. 87-97, 2000.

Application Library path: MEMS_Module/Piezoelectric_Devices/

```
piezoceramic_tube
```


## Modeling Instructions

From the File menu, choose New.

## N E W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D Axisymmetric.
2 In the Select Physics tree, select Structural Mechanics>Piezoelectric Devices.
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces>Stationary.
6 Click Done.

## GEOMETRY I

I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.

3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Create the tube by adding an off-axis rectangle in the axisymmetric geometry.
Rectangle I (rl)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 240.
4 In the Height text field, type 620.
5 Locate the Position section. In the $\mathbf{r}$ text field, type 380.
6 Click Build All Objects.
Add a PZT 5H to the model.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select Piezoelectric>Lead Zirconate Titanate (PZT-5H).
4 Click Add to Component in the window toolbar.
5 On the Home toolbar, click Add Material to close the Add Material window.

## SOLID MECHANICS (SOLID)

## Piezoelectric Material I

I In the Model Builder window, under Component I (compl)>Solid Mechanics (solid) click Piezoelectric Material I.

2 In the Settings window for Piezoelectric Material, locate the Coordinate System Selection section.

3 From the Coordinate system list, choose Material ZX-Plane System (compl_zx_sys).
By selecting the material orientation as the $z x$-plane, you rotate the material so that its $z$ direction is aligned with the $r$ direction of the model, and the material's $x$ direction is aligned with the model's $z$ direction.

This example comprises two studies: the direct effect and inverse effect. All loadings for both studies are defined together and then a selection of relevant features will be done in the study settings.

Add a pressure follower load to the inner surface of the cylinder.

## Boundary Load I

I In the Model Builder window, right-click Solid Mechanics (solid) and choose Boundary Load.

2 Select Boundary 1 only.
3 In the Settings window for Boundary Load, locate the Force section.
4 From the Load type list, choose Pressure.
5 In the $p$ text field, type 0.1 [MPa].
Constrain the lower surface of the tube with a roller boundary condition.

## Roller I

I Right-click Solid Mechanics (solid) and choose Roller.
2 Select Boundary 2 only.

ELECTROSTATICS (ES)
Ground both the inner and outer surfaces of the cylinder.
Ground I
I In the Model Builder window, under Component I (compl) right-click Electrostatics (es) and choose Ground.

2 Select Boundaries 1 and 4 only.
Add an electric potential feature on the outer boundary. This will over-ride the existing Ground feature.

## Electric Potential I

I In the Model Builder window, right-click Electrostatics (es) and choose Electric Potential.
2 Select Boundary 4 only.
3 In the Settings window for Electric Potential, locate the Electric Potential section.
4 In the $V_{0}$ text field, type 1.

## MESH I

Create a mapped mesh.

## Mapped I

I In the Model Builder window, under Component I (compl) right-click Mesh I and choose Mapped.

2 In the Settings window for Mapped, click Build All.

## STUDY I

The first study simulates the direct effect. All mechanical loads are kept and the electric potential feature is disabled in solver settings. It is automatically replaced by the ground feature that was previously overridden.

## Step I: Stationary

I In the Model Builder window, under Study I click Step I: Stationary.
2 In the Settings window for Stationary, locate the Physics and Variables Selection section.
3 Select the Modify physics tree and variables for study step check box.
4 In the Physics and variables selection tree, select Component I (compl)> Electrostatics (es)>Electric Potential I.

5 Click Disable.
6 On the Home toolbar, click Compute.

## RESULTS

## Stress (solid)

The default plot groups show stress in the tube and the induced electric potential. Adapt these for comparison with. First replace stress plot by radial displacement.

I In the Model Builder window, under Results click Stress (solid).
2 In the Settings window for 2D Plot Group, type Radial Displacement (Direct Effect) in the Label text field.

## Surface I

I In the Model Builder window, expand the Results>Radial Displacement (Direct Effect) node, then click Surface I.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>Displacement field (material and geometry frames) $>\mathbf{u}$ - Displacement field, R component.
3 On the Radial Displacement (Direct Effect) toolbar, click Plot.

## Stress, 3D (solid)

I In the Model Builder window, under Results click Stress, 3D (solid).
2 In the Settings window for 3D Plot Group, type Stress, 3D (Direct Effect) in the Label text field.

## Electric Potential (es)

I In the Model Builder window, under Results click Electric Potential (es).
2 In the Settings window for 2D Plot Group, type Electric Potential (Direct Effect) in the Label text field.

## Electric Potential, Revolved Geometry (es)

Change the data set of the potential plot in order to see a 3 D cut view of the potential.
I In the Model Builder window, under Results click Electric Potential, Revolved Geometry (es).

2 In the Settings window for 3D Plot Group, type Electric Potential, 3D (Direct Effect) in the Label text field.

3 Locate the Data section. From the Data set list, choose Revolution 2D I.
4 On the Electric Potential, 3D (Direct Effect) toolbar, click Plot.

## Data Sets

Create a cross section through the geometry to use for line plots of the electric potential and displacement.

Cut Line 2D I
I On the Results toolbar, click Cut Line 2D.
2 In the Settings window for Cut Line 2D, locate the Line Data section.
3 In row Point I, set $\mathbf{r}$ to 380 and $\mathbf{z}$ to 300.
4 In row Point 2, set $\mathbf{r}$ to 620 and $\mathbf{z}$ to 300 .
Visualize the cross section line.
5 Click Plot.
Add line plots of the radial displacement and the potential along the cross section.

## ID Plot Group 5

I On the Results toolbar, click ID Plot Group.
2 In the Settings window for ID Plot Group, type Radial Displacement, cut (Direct Effect) in the Label text field.

3 Locate the Data section. From the Data set list, choose Cut Line 2D I.

## Line Graph I

I Right-click Radial Displacement, cut (Direct Effect) and choose Line Graph.
2 In the Model Builder window, click Line Graph I.

3 In the Settings window for Line Graph, click Replace Expression in the upper-right corner of the $\mathbf{y}$-axis data section. From the menu, choose Component I $>$ Solid Mechanics> Displacement $>$ Displacement field (material and geometry frames) $>\mathbf{u}$ - Displacement field, R component.

4 Locate the y-Axis Data section. From the Unit list, choose nm.
5 Locate the x-Axis Data section. From the Parameter list, choose Expression.
6 In the Expression text field, type r.
7 On the Radial Displacement, cut (Direct Effect) toolbar, click Plot.

## Radial Displacement, cut (Direct Effect) I

I In the Model Builder window, under Results right-click Radial Displacement, cut (Direct Effect) and choose Duplicate.

2 In the Settings window for ID Plot Group, type Voltage, Cut (Direct Effect) in the Label text field.

## Line Graph I

I In the Model Builder window, expand the Results>Voltage, Cut (Direct Effect) node, then click Line Graph I.

2 In the Settings window for Line Graph, locate the $\boldsymbol{y}$-Axis Data section.
3 In the Expression text field, type abs (V).
4 On the Voltage, Cut (Direct Effect) toolbar, click Plot.
Finally add a new study to compute the results for the inverse effect.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies>Stationary.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

The second study simulates the inverse effect. All electrical loads are kept and the pressure load feature is disabled in solver settings. It is automatically replaced by the Free boundary feature that was previously overridden.

## Step I: Stationary

I In the Model Builder window, under Study 2 click Step I: Stationary.

2 In the Settings window for Stationary, locate the Physics and Variables Selection section.
3 Select the Modify physics tree and variables for study step check box.
4 In the Physics and variables selection tree, select Component I (compl)> Solid Mechanics (solid)>Boundary Load I.

5 Click Disable.
6 On the Home toolbar, click Compute.

## RESULTS

## Stress (solid)

I In the Model Builder window, under Results click Stress (solid).
2 In the Settings window for 2D Plot Group, type Radial Displacement (Inverse Effect) in the Label text field.

## Surface I

I In the Model Builder window, expand the Results>Radial Displacement (Inverse Effect) node, then click Surface I.

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>Displacement field (material and geometry frames) $>\mathbf{u}$ - Displacement field, R component.
3 On the Radial Displacement (Inverse Effect) toolbar, click Plot.

## Stress, 3D (solid)

I In the Model Builder window, under Results click Stress, 3D (solid).
2 In the Settings window for 3D Plot Group, type Stress, 3D (Inverse Effect) in the Label text field.

## Electric Potential (es)

I In the Model Builder window, under Results click Electric Potential (es).
2 In the Settings window for 2D Plot Group, type Electric Potential (Inverse Effect) in the Label text field.

## Electric Potential, Revolved Geometry (es)

I In the Model Builder window, under Results click Electric Potential, Revolved Geometry (es).

2 In the Settings window for 3D Plot Group, locate the Data section.
3 From the Data set list, choose Revolution 2D 3.

4 In the Label text field, type Electric Potential, 3D (Inverse Effect).
5 On the Electric Potential, 3D (Inverse Effect) toolbar, click Plot.
Create a second Cut Line 2D for the new solution.

## Cut Line 2D 2

I In the Model Builder window, under Results>Data Sets right-click Cut Line 2D I and choose Duplicate.

2 In the Settings window for Cut Line 2D, locate the Data section.
3 From the Data set list, choose Study 2/Solution 2 (sol2).
Radial Displacement, cut (Direct Effect) I
I In the Model Builder window, under Results right-click Radial Displacement, cut (Direct Effect) and choose Duplicate.

2 In the Settings window for ID Plot Group, type Radial Displacement, cut (Inverse Effect) in the Label text field.

3 Locate the Data section. From the Data set list, choose Cut Line 2D 2.
4 On the Radial Displacement, cut (Inverse Effect) toolbar, click Plot.

## Voltage, Cut (Direct Effect) I

I In the Model Builder window, under Results right-click Voltage, Cut (Direct Effect) and choose Duplicate.

2 In the Settings window for ID Plot Group, type Voltage, Cut (Inverse Effect) in the Label text field.

3 Locate the Data section. From the Data set list, choose Cut Line 2D 2.
4 On the Voltage, Cut (Inverse Effect) toolbar, click Plot.

## Piezoelectric Valve

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## Introduction

Piezoelectric valves are frequently employed in medical and laboratory applications. They have a number of advantages over competing technologies, including minimal heat dissipation, quiet operation, energy efficiency, durability, low weight and fast response times. These valves typically consist of a seal that is pushed up against an opening to close the valve, or moved away from the opening to open the valve, by a piezoelectric actuator. The actuator itself often has a complex internal structure, with stacked layers of piezoelectric separated by thin conducting layers that are connected together in such a way that the applied field leads to a large deformation.

This model shows how to model a piezoelectric valve in COMSOL. The valve is actuated by a stacked piezoelectric bimorph disc actuator, which compresses a hyper-elastic seal against the valve opening to shut off the flow. The detailed construction and operation of the stacked actuator is considered in the model.

Note: This application requires the Nonlinear Structural Materials Module.

## Model Definition

Figure 1 shows both an axisymmetric slice through the geometry and a 3D rendering of the geometry. In this simple valve design a disc actuator compresses a hyperelastic seal directly onto an annular opening in a stainless steal support structure. The construction of the actuator itself is illustrated in Figure 2. The outer edge of the disc annulus is clamped to a stainless steel base and supporting structure. When a voltage is applied to the actuator the disc bends causing a vertical motion of the central opening of the annular actuator. With an appropriate polarity the opening moves downward, towards an annular opening in the base (supported at regular intervals by struts not included in the model). As the actuator moves towards the opening a hyperelastic seal is compressed against a mating structure, sealing up the opening. Within the model, the contact between the seal and the mating structure is modeled in detail, as is the operation of the actuator.


Figure 1: Axisymmetric model geometry (top) and full 3D geometry (bottom). Key components of the geometry are labeled.


Figure 2: Detail of the actuator and seal region, showing the construction of the actuator itself. The actuator consists of layers of PZT with metal layers between the various layers. Alternate metal layers are connected to ground whilst a voltage is applied to the other layers. Alternate layers of PZT are polarized in opposite directions. Two such actuators are stacked in such a manner that the applied potential causes contraction of one half of the beam and expansion of the other balf. This results in a net bending moment acting on the beam.

## Results and Discussion

Figure 3 shows the strain in the hyperelastic seal when the applied voltage is 60 V . The strain is localized in the vicinity of the contact region. Figure 4 shows the von Mises strain in the piezoelectric and its supporting structures at the same applied voltage. The stress is maximal in the PZT close to the contact. The potential within the actuator is shown in Figure 5. It is clear that the applied potentials match those shown in Figure 2. Finally the contact pressure is shown in Figure 6. The maximum pressure is $6 \times 10^{5} \mathrm{~Pa}$ on the surface of the seal that separates the inlet of the valve from the outlet.


Figure 3: ZZ component of the strain in the vicinity of the contact.
$\mathrm{V} 0(13)=60 \mathrm{~V}$ Surface: von Mises stress $\left(\mathrm{N} / \mathrm{m}^{2}\right)$


Figure 4: Three-dimensional visualization of the von Mises stress in the valve at an applied voltage of 50 V .


Figure 5: Electric potential inside the actuator in the vicinity of the contact.


Figure 6: Contact pressure as a function of position along the surface of the seal.

Application Library path: MEMS_Module/Piezoelectric_Devices/
piezoelectric_valve

## Modeling Instructions

From the File menu, choose New.

## N E W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D Axisymmetric.
2 In the Select Physics tree, select Structural Mechanics>Piezoelectric Devices.
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces>Stationary.
6 Click Done.
For convenience, the device geometry is inserted from an existing file. You can read the instructions for creating the geometry in the .

## GEOMETRY I

I On the Geometry toolbar, click Insert Sequence.
2 Browse to the model's Application Libraries folder and double-click the file piezoelectric_valve_geom_sequence.mph.

3 On the Geometry toolbar, click Build All.

## GLOBAL DEFINITIONS

## Parameters

I In the Model Builder window, expand the Global Definitions node, then click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.

3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| V0 | $50[\mathrm{~V}]$ | 50 V | Applied voltage |

## DEFINITIONS

## Explicit I

I On the Definitions toolbar, click Explicit.
2 Select Domains 5, 7, 9, 10, 12, 14, 18, 20, 22, 23, 25, 27, 32, 34, 36, 37, 39, 41, 47, $49,51,52,54$, and 56 only.
3 In the Settings window for Explicit, type + Polarized in the Label text field.

## Explicit 2

I On the Definitions toolbar, click Explicit.
2 In the Settings window for Explicit, type - Polarized in the Label text field.
3 Select Domains $4,6,8,11,13,15,17,19,21,24,26,28,31,33,35,38,40,42,46$, $48,50,53,55$, and 57 only.

## Union I

I On the Definitions toolbar, click Union.
2 In the Settings window for Union, type Piezoelectric in the Label text field.
3 Locate the Input Entities section. Under Selections to add, click Add.
4 In the Add dialog box, In the Selections to add list, choose + Polarized and - Polarized.
5 Click OK.

## Explicit 3

I On the Definitions toolbar, click Explicit.
2 On the Definitions toolbar, click Explicit.
3 In the Settings window for Explicit, locate the Input Entities section.
4 From the Geometric entity level list, choose Boundary.
5 In the Label text field, type Ground.
6 Select Boundaries $10,14,18,22,26,30,33,36,40,44,48,52,56,59,76,80,84$, $88,92,96,99,109,113,117,121,125,129$, and 133 only.

## Explicit 4

I On the Definitions toolbar, click Explicit.

2 In the Settings window for Explicit, type Voltage in the Label text field.
3 Locate the Input Entities section. From the Geometric entity level list, choose Boundary.
4 Select Boundaries $12,16,20,24,28,32,38,42,46,50,54,58,78,82,86,90,94$, $98,111,115,119,123,127$, and 131 only.

## Explicit 5

I In the Model Builder window, under Component I (compl)>Definitions click Explicit 5.
2 In the Settings window for Explicit, type Mapped Mesh Steel in the Label text field.
3 Select Domains 1, 2, 29, 43, and 44 only.

## Union 2

I On the Definitions toolbar, click Union.
2 In the Settings window for Union, locate the Input Entities section.
3 Under Selections to add, click Add.
4 In the Add dialog box, In the Selections to add list, choose Piezoelectric and Mapped Mesh Steel.

5 Click OK.
6 In the Settings window for Union, type Mapped Mesh in the Label text field.

## Contact Pair I (pl)

I On the Definitions toolbar, click Pairs and choose Contact Pair.
2 Select Boundaries 8, 62, 71, 72, and 150-153 only.
3 In the Settings window for Pair, locate the Destination Boundaries section.
4 Select the Active toggle button.
5 Select Boundaries 61 and 66 only.

## Material XZ-Plane System (comp I_xz_sys)

I In the Model Builder window, under Component I (compI)>Definitions click Material XZPlane System (comp I_xz_sys).

2 In the Settings window for Base Vector System, type $+Z$ Polarized in the Label text field.
+Z Polarized I (compl_xz_sysl)
I Right-click Component I (compI)>Definitions>+Z Polarized and choose Duplicate.
2 In the Settings window for Base Vector System, locate the Settings section.

3 Find the Base vectors subsection. In the table, enter the following settings:

|  | $\mathbf{r}$ | $\mathbf{z}$ |
| :--- | :--- | :--- |
| $\mathbf{x I}$ | 1 | 0 |
| x3 | 0 | -1 |

4 In the Label text field, type -Z Polarized.

SOLID MECHANICS (SOLID)
In the Model Builder window, expand the Component I (comp I) $>$ Solid Mechanics (solid) node.

## Piezoelectric Material 2

I Right-click Solid Mechanics (solid) and choose Material Models>Piezoelectric Material.
2 In the Settings window for Piezoelectric Material, locate the Coordinate System Selection section.

3 From the Coordinate system list, choose -Z Polarized (compl_xz_sysl).
4 Locate the Domain Selection section. From the Selection list, choose - Polarized.

## Piezoelectric Material I

I In the Model Builder window, under Component I (compl)>Solid Mechanics (solid) click Piezoelectric Material I.

2 In the Settings window for Piezoelectric Material, locate the Domain Selection section.
3 From the Selection list, choose + Polarized.

## Hyperelastic Material I

I In the Model Builder window, right-click Solid Mechanics (solid) and choose Material Models>Hyperelastic Material.

2 Select Domain 16 only.
3 In the Settings window for Hyperelastic Material, locate the Hyperelastic Material section.
4 From the Material model list, choose Mooney-Rivlin, two parameters.
5 In the $\kappa$ text field, type $1 \mathrm{e} 4[\mathrm{MPa}$.

## Fixed Constraint I

I Right-click Solid Mechanics (solid) and choose Domain Constraints>Fixed Constraint.
2 Select Domains 1, 2, 29, 43, and 44 only.

## Contact I

I Right-click Solid Mechanics (solid) and choose Pairs>Contact.

2 In the Settings window for Contact, locate the Pair Selection section.
3 In the Pairs list, select Contact Pair I (pI).

## ELECTROSTATICS (ES)

I In the Model Builder window, under Component I (compl) click Electrostatics (es).
2 In the Settings window for Electrostatics, locate the Domain Selection section.
3 From the Selection list, choose Piezoelectric.

## Terminal I

I Right-click Component I (compl)>Electrostatics (es) and choose the boundary condition Terminal.

2 In the Settings window for Terminal, locate the Boundary Selection section.
3 From the Selection list, choose Voltage.
4 Locate the Terminal section. From the Terminal type list, choose Voltage.
5 In the $V_{0}$ text field, type $V 0$.

## Ground I

I In the Model Builder window, right-click Electrostatics (es) and choose Ground.
2 In the Settings window for Ground, locate the Boundary Selection section.
3 From the Selection list, choose Ground.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select Piezoelectric>Lead Zirconate Titanate (PZT-5H).
4 Click Add to Component I.

## MATERIALS

Lead Zirconate Titanate (PZT-5H) (matl)
I In the Model Builder window, under Component I (compl)>Materials click Lead Zirconate Titanate (PZT-5H) (matI).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Piezoelectric.

ADD MATERIAL
I Go to the Add Material window.

2 In the tree, select Built-In>Steel AISI 4340.
3 Click Add to Component I.

## MATERIALS

Steel AISI 4340 (mat2)
I In the Model Builder window, under Component I (compl)>Materials click Steel AISI 4340 (mat2).

2 Select Domains 1-3, 29, 30, and 43-45 only.

## Material 3 (mat3)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, type Seal in the Label text field.
3 Select Domain 16 only.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- |
| Density | rho | $1800\left[\mathrm{~kg} / \mathrm{m}^{\wedge} 3\right]$ | $\mathrm{kg} / \mathrm{m}^{3}$ | Basic |
| Model parameters | CIO | $0.37[\mathrm{MPa}]$ | Pa | Mooney-Rivlin |
| Model parameters | COI | $0.11[\mathrm{MPa}]$ | Pa | Mooney-Rivlin |

5 On the Home toolbar, click Add Material to close the Add Material window.

## MESH I

## Edge I

I In the Model Builder window, under Component I (comp I) right-click Mesh I and choose More Operations>Edge.

2 Select Boundaries 61, 62, 66, 71, and 150-153 only.

## Size I

I Right-click Component I (compI)>Mesh I>Edge I and choose Size.
2 In the Settings window for Size, locate the Geometric Entity Selection section.
3 Click Clear Selection.
4 Select Boundaries 61 and 66 only.
5 Locate the Element Size section. From the Predefined list, choose Extremely fine.
6 Click the Custom button.

7 Locate the Element Size Parameters section. Select the Maximum element size check box. 8 In the associated text field, type wo/100.

Size 2
I Right-click Edge I and choose Size.
2 In the Settings window for Size, locate the Geometric Entity Selection section.
3 Click Clear Selection.
4 Select Boundaries 62, 71, and 150-153 only.
5 Locate the Element Size section. From the Predefined list, choose Extremely fine.
6 Click the Custom button.
7 Locate the Element Size Parameters section. Select the Maximum element size check box.
8 In the associated text field, type wo/50.

## Size

I In the Model Builder window, under Component I (compl)>Mesh I click Size.
2 In the Settings window for Size, locate the Element Size section.
3 From the Predefined list, choose Extremely fine.
4 Click the Custom button.
5 Locate the Element Size Parameters section. In the Maximum element size text field, type wo.

## Mapped I

I In the Model Builder window, right-click Mesh I and choose Mapped.
2 In the Settings window for Mapped, locate the Domain Selection section.
3 From the Geometric entity level list, choose Domain.
4 From the Selection list, choose Mapped Mesh.
Distribution I
I Right-click Component I (compl)>Mesh I>Mapped I and choose Distribution.
2 Select Boundaries $75,77,79,81,83,85,87,89,91,93,95$, and 97 only.
3 In the Settings window for Distribution, locate the Distribution section.
4 In the Number of elements text field, type 2.

## Distribution 2

I Right-click Mapped I and choose Distribution.
2 Select Boundaries 36 and 109 only.

3 In the Settings window for Distribution, locate the Distribution section.
4 In the Number of elements text field, type 40.
Distribution 3
I Right-click Mapped I and choose Distribution.
2 In the Settings window for Distribution, locate the Distribution section.
3 In the Number of elements text field, type 1.
4 Select Boundaries 2, 63, 67, and 101 only.
5 In the Model Builder window, right-click Mesh I and choose Free Triangular.
6 In the Settings window for Mesh, click Build All.
Compare the resulting mesh with that shown below. Note that there are purposefully very few elements in the rigid domains.


## STUDY I

Step I: Stationary
I In the Settings window for Stationary, click to expand the Study extensions section.
2 Locate the Study Extensions section. Select the Auxiliary sweep check box.
3 Click Add.

4 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| V0 |  |  |

5 Click Range.
6 In the Range dialog box, type 0 in the Start text field.
7 In the Step text field, type 5.
8 In the Stop text field, type 60.
9 Click Add.
10 In the Settings window for Stationary, locate the Study Extensions section.
II In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :---: | :--- |
| V0 | range $(0,5,60)$ | V |

When modeling contact both the contact pressure and the auxiliary pressure need to be manually scaled. It is good practice to modify the manual scaling of these variables to an appropriate value.

## Solution I (soll)

I On the Study toolbar, click Show Default Solver.
2 In the Model Builder window, expand the Solution I (soll) node.
The contact pressure is expected to be of the order of MPa , so set the scales accordingly.
3 In the Model Builder window, expand the Study I>Solver Configurations>
Solution I (solI)>Dependent Variables I node, then click
Auxiliary pressure (compl.solid.pw).
4 In the Settings window for Field, locate the Scaling section.
5 In the Scale text field, type 1 e6.
6 In the Model Builder window, under Study I>Solver Configurations>Solution I (solI)> Dependent Variables I click Contact pressure (compl.solid.Tn_pI).
7 In the Settings window for Field, locate the Scaling section.
8 In the Scale text field, type 1 e6.
9 On the Study toolbar, click Compute.

## RESULTS

## 2D Plot Group 5

I On the Home toolbar, click Add Plot Group and choose 2D Plot Group.
2 In the Settings window for 2D Plot Group, type Strain (ZZ component) in the Label text field.

3 Locate the Plot Settings section. From the Frame list, choose Spatial (r, phi, z).

## Surface I

I Right-click Strain (ZZ component) and choose Surface.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics>Strain> Strain tensor (material and geometry frames)>solid.eZZ - Strain tensor, ZZ component.
3 Locate the Coloring and Style section. Select the Reverse color table check box.
4 On the Strain (ZZ component) toolbar, click Plot.
Zoom in on the contact region and compare the plot with .
5 Click the Zoom Box button on the Graphics toolbar.

## Strain (ZZ component) I

I In the Model Builder window, under Results right-click Strain (ZZ component) and choose Duplicate.

2 In the Settings window for 2D Plot Group, type Electric Field (Z component) in the Label text field.

## Surface I

I In the Model Builder window, expand the Strain (ZZ component) I node, then click Results $>$ Electric Field (Z component) $>$ Surface I.

2 In the Settings window for Surface, click to collapse the Expression section.
3 Click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Electrostatics>Electric>
Electric field (material and geometry frames)>es.EZ - Electric field, Z component.
4 On the Electric Field (Z component) toolbar, click Plot.

## ID Plot Group 7

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, type Contact Pressure in the Label text field.

3 Locate the Data section. From the Parameter selection (VO) list, choose Last.

## Line Graph I

I Right-click Contact Pressure and choose Line Graph.
2 Select Boundaries 60, 61, 65, 66, and 73 only.
3 In the Settings window for Line Graph, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I>Solid Mechanics> Contact>solid.Tn - Contact pressure.

4 On the Contact Pressure toolbar, click Plot.

## Appendix - Geometry Instructions

From the File menu, choose New.

## N E W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D Axisymmetric.
2 Click Done.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| t0 | $0.05[\mathrm{~mm}]$ | $5 \mathrm{E}-5 \mathrm{~m}$ | Piezoelectric layer thickness |
| ID | $7[\mathrm{~mm}]$ | 0.007 m | Disc actuator inner diameter |
| OD | $50[\mathrm{~mm}]$ | 0.05 m | Disc actuator outer diameter |
| n | 12 | 12 | Number of layers in actuator |
| ts | $0.2[\mathrm{~mm}]$ | $2 \mathrm{E}-4 \mathrm{~m}$ | Thickness of seal |
| w0 | $0.5[\mathrm{~mm}]$ | $5 \mathrm{E}-4 \mathrm{~m}$ | Through hole dimension |
| w1 | ID $/ 2$ | 0.0035 m | Clamp region dimension |
| w2 | ID $/ 4$ | 0.00175 m | Overall clamp dimension |


| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| h0 | $5 *$ t0*n | 0.003 m | Base thickness |
| deltaz | $16[\mathrm{um}]$ | $1.6 \mathrm{E}-5 \mathrm{~m}$ | Contact offset at 0[V] |

## GEOMETRY I

## Rectangle I (rl)

I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type (OD-ID)/2.
4 In the Height text field, type to.
5 Locate the Position section. In the $\mathbf{r}$ text field, type ID/2.
6 In the $\mathbf{z}$ text field, type $t$.
7 Click to expand the Layers section. Select the Layers to the left check box.
8 Clear the Layers on bottom check box.
9 In the table, enter the following settings:

| Layer name | Thickness (m) |
| :--- | :--- |
| Layer 1 | $0.5^{*} \mathrm{w} 0$ |
| Layer 2 | $3 * \mathrm{w} 0$ |

Array I (arrl)
I On the Geometry toolbar, click Transforms and choose Array.
2 In the Settings window for Array, locate the Size section.
3 In the $\mathbf{z}$ size text field, type $n$.
4 Locate the Displacement section. In the $\mathbf{z}$ text field, type t 0 .
5 Select the object $\mathbf{r}$ only.

## Rectangle 2 (r2)

I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type $3^{*}$ wo.
4 In the Height text field, type ts.
5 Locate the Position section. In the $\mathbf{r}$ text field, type ID/2+0.5*w0.

## Fillet I (fill)

I On the Geometry toolbar, click Fillet.
2 On the object $\mathbf{r 2}$, select Points 1 and 2 only.
3 In the Settings window for Fillet, locate the Radius section.
4 In the Radius text field, type $\mathrm{ts} / 3$.
Rectangle 3 (r3)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type $2 *$ wo.
4 In the Height text field, type $2^{*} w 0+h 0$.
5 Locate the Position section. In the $\mathbf{r}$ text field, type ID/2-0.5*w0.
6 In the $\mathbf{z}$ text field, type $-2 *$ wo-deltaz-ho.

## Chamfer I (chal)

I On the Geometry toolbar, click Chamfer.
2 On the object $\mathbf{r} 3$, select Point 4 only.
3 In the Settings window for Chamfer, locate the Distance section.
4 In the Distance from vertex text field, type 1.8*wo.
Fillet 2 (fil2)
I On the Geometry toolbar, click Fillet.
2 On the object chal, select Points 3 and 5 only.
3 In the Settings window for Fillet, locate the Radius section.
4 In the Radius text field, type $0.1 *$ w 0 .
Polygon I (poll)
I On the Geometry toolbar, click Primitives and choose Polygon.
2 In the Settings window for Polygon, locate the Coordinates section.
3 In the $\mathbf{r}$ text field, type ID/2+1.2*w0 ID/2+1.6*w0.
4 In the $\mathbf{z}$ text field, type 00.
Mirror I (mirl)
I On the Geometry toolbar, click Transforms and choose Mirror.
2 Select the objects poll and fil2 only.
3 In the Settings window for Mirror, locate the Input section.

4 Select the Keep input objects check box.
5 Locate the Point on Line of Reflection section. In the $\mathbf{r}$ text field, type ID/2+2*wo.
Rectangle 4 (r4)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type ID $/ 2+1.5^{*}$ wo.
4 In the Height text field, type ho.
5 Locate the Position section. In the $\mathbf{z}$ text field, type - $2 *$ wo-deltaz-ho.

## Rectangle 5 (r5)

I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 0D/2+w1-ID/2-2.5*w0.
4 In the Height text field, type ho.
5 Locate the Position section. In the $\mathbf{r}$ text field, type ID/2+2.5*w0.
6 In the $\mathbf{z}$ text field, type -2*wo-deltaz-ho.
Rectangle 6 ( r 6 )
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type w2+w1.
4 In the Height text field, type $\mathrm{h} 0+4 * \mathrm{w} 0+\mathrm{n} *$ to $0+$ deltaz.
5 Locate the Position section. In the $\mathbf{r}$ text field, type 0D/2-w2.
6 In the $\mathbf{z}$ text field, type $-2 * w 0-$ deltaz-ho.
7 Click Build Selected.

## Piezoresistive Pressure Sensor

## Introduction

Piezoresistive pressure sensors were some of the first MEMS devices to be commercialized.
Compared to capacitive pressure sensors, they are simpler to integrate with electronics, their response is more linear, and they are inherently shielded from RF noise. They do, however, usually require more power during operation, and the fundamental noise limits of the sensor are higher than their capacitive counterparts. Historically, piezoresistive devices have been dominant in the pressure sensor market.

This example considers the design of the MPX100 series pressure sensors originally produced by the semiconductor products division of Motorola Inc. (now Freescale Semiconductor Inc.). Although the sensor is no longer in production, a detailed analysis of its design is given in Ref. 1, and an archived data sheet is available from Freescale Semiconductor Inc. (Ref. 2).

## Model Definition

The model consists square membrane with side 1 mm and thickness $20 \mu \mathrm{~m}$, supported around its edges by region 0.1 mm wide, which is intended to represent the remainder of the wafer. The supporting region is fixed on its underside (representing a connection to the thicker handle of the device die). Near to one edge of the membrane an X-shaped piezoresistor (or Xducer $\left.{ }^{\mathrm{TM}}\right)^{1}$ and part of its associated interconnects are visible. The geometry is shown in Figure 1.
The piezoresistor is assumed to have a uniform p-type dopant density of $1.32 \times 10^{19} \mathrm{~cm}^{-3}$ and a thickness of 400 nm . The interconnects are assumed to have the same thickness but a dopant density of $1.45 \times 10^{20} \mathrm{~cm}^{-3}$. Only a part of the interconnects is included in the geometry, since their conductivity is sufficiently high that they do not contribute to the voltage output of the device (in practice the interconnects would also be thicker in addition to having a higher conductivity but this also has little effect on the solution).

The edges of the die are aligned with the $\{110\}$ directions of the silicon. The die edges are also aligned with the global $X$ and $Y$ axes in the COMSOL model. The piezoresistor is oriented at 45 to the die edge, and so lies in the [100] direction of the crystal. In the

[^0]COMSOL model, a coordinate system rotated 45 about the global $Z$-axis is added to define the orientation of the crystal.


Figure 1: Left: Model geometry. Right: Detail showing the piezoresistor geometry.

## DEVICE PHYSICS AND EQUATIONS

The conductivity of the Xducer ${ }^{\text {TM }}$ sensor changes when the membrane in its vicinity is subject to an applied stress. This effect is known as the piezoresistance effect and is usually associated with semiconducting materials. In semiconductors, piezoresistance results from the strain-induced alteration of the material's band structure, and the associated changes in carrier mobility and number density. The relation between the electric field, $E$, and the current, $J$, within a piezoresistor is:

$$
\begin{equation*}
\mathbf{E}=\rho \cdot \mathbf{J}+\Delta \rho \cdot \mathbf{J} \tag{1}
\end{equation*}
$$

where $\rho$ is the resistivity and $\Delta \rho$ is the induced change in the resistivity. In the general case both $\rho$ and $\Delta \rho$ are rank 2 tensors (matrices). The change in resistance is related to the stress, $\sigma$, by the constitutive relationship:

$$
\begin{equation*}
\Delta \rho=\Pi \cdot \sigma \tag{2}
\end{equation*}
$$

where $\Pi$ is the piezoresistance tensor (SI units: $\mathrm{Pa}^{-1} \Omega \mathrm{~m}$ ), a material property. Note that COMSOL's definition of $\Pi$ includes the resistivity in each element of the tensor, rather than having a scalar multiple outside of $\Pi$ (which is possible only for materials with isotropic conductivity). $\Pi$ is in this case a rank- 4 tensor; however, it can be represented as a matrix if the resistivity and stress are converted to vectors within a reduced subscript notation. Within the Voigt notation employed by COMSOL for this purpose, Equation 2 becomes:

$$
\left[\begin{array}{c}
\Delta \rho_{x x}  \tag{3}\\
\Delta \rho_{y y} \\
\Delta \rho_{z z} \\
\Delta \rho_{y z} \\
\Delta \rho_{x z} \\
\Delta \rho_{x y}
\end{array}\right]=\left[\begin{array}{llllll}
\Pi_{11} & \Pi_{12} & \Pi_{13} & \Pi_{14} & \Pi_{15} & \Pi_{16} \\
\Pi_{21} & \Pi_{22} & \Pi_{23} & \Pi_{24} & \Pi_{25} & \Pi_{26} \\
\Pi_{31} & \Pi_{32} & \Pi_{33} & \Pi_{34} & \Pi_{35} & \Pi_{36} \\
\Pi_{41} & \Pi_{42} & \Pi_{43} & \Pi_{44} & \Pi_{45} & \Pi_{46} \\
\Pi_{51} & \Pi_{52} & \Pi_{53} & \Pi_{54} & \Pi_{55} & \Pi_{56} \\
\Pi_{61} & \Pi_{62} & \Pi_{63} & \Pi_{64} & \Pi_{65} & \Pi_{66}
\end{array}\right] \cdot\left[\begin{array}{c}
\sigma^{x x} \\
\sigma^{y y} \\
\sigma^{z z} \\
\sigma^{y z} \\
\sigma^{x z} \\
\sigma^{x y}
\end{array}\right]
$$

The $\Delta \rho$ vector computed from Equation 3 is assembled into matrix form in the following manner in Equation 1:

$$
\left[\begin{array}{c}
E_{x}  \tag{4}\\
E_{y} \\
E_{z}
\end{array}\right]=\left[\begin{array}{lll}
\rho_{x x} & \rho_{x y} & \rho_{x z} \\
\rho_{x y} & \rho_{y y} & \rho_{y z} \\
\rho_{x z} & \rho_{y z} & \rho_{z z}
\end{array}\right] \cdot\left[\begin{array}{c}
J_{x} \\
J_{y} \\
J_{z}
\end{array}\right]+\left[\begin{array}{ccc}
\Delta \rho_{x x} & \Delta \rho_{x y} & \Delta \rho_{x z} \\
\Delta \rho_{x y} & \Delta \rho_{y y} & \Delta \rho_{y z} \\
\Delta \rho_{x z} & \Delta \rho_{y z} & \Delta \rho_{z z}
\end{array}\right] \cdot\left[\begin{array}{c}
J_{x} \\
J_{y} \\
J_{z}
\end{array}\right]
$$

Silicon has cubic symmetry, and as a result the $\Pi$ matrix can be described in terms of three independent constants in the following manner:

$$
\Pi=\left[\begin{array}{cccccc}
\Pi_{11} & \Pi_{12} & \Pi_{12} & 0 & 0 & 0 \\
\Pi_{12} & \Pi_{22} & \Pi_{12} & 0 & 0 & 0 \\
\Pi_{12} & \Pi_{12} & \Pi_{33} & 0 & 0 & 0 \\
0 & 0 & 0 & \Pi_{44} & 0 & 0 \\
0 & 0 & 0 & 0 & \Pi_{44} & 0 \\
0 & 0 & 0 & 0 & 0 & \Pi_{44}
\end{array}\right]
$$

For p-type silicon the $\Pi_{44}$ constant is two orders of magnitude larger than either the $\Pi_{11}$ or the $\Pi_{12}$ coefficients. The $\Pi_{66}$ element (which is equal in magnitude to the $\Pi_{44}$ element) couples the $\sigma_{x y}$ shear stress, with the $\Delta \rho_{x y}$ off-diagonal term in the change in resistivity matrix. In turn, $\Delta \rho_{x y}$ couples a current in the $x$-direction to an induced electric field in the $y$-direction (and vice versa). This is the principle of the Xducer ${ }^{\text {TM }}$ transducer. An applied voltage (typically 3 V ; see Ref. 2) across the [100] orientated arm of the X produces a current (typically 6 mA ; see Ref. 2) down this arm. Shear stresses are present in the Xducer ${ }^{\text {TM }}$ as a result of the pressure induced deformation of the diaphragm in which it is implanted. Through the piezoresistance effect, these shear stresses cause an electric field or potential gradient transverse to the direction of current flow, in the [010] arm of the X .

Across the width of the transducer, the potential gradient sums up to produce an induced voltage difference between the [010] arms of the X. According to the device data sheet, under normal operating conditions a 60 mV potential difference is generated from a 100 kPa applied pressure with a 3 V applied bias (Ref. 2).

The situation is complicated somewhat by the detailed current distribution within the device, since the voltage sensing elements increase the width of the current carrying silicon wire locally, leading to a "short circuit" effect (Ref. 3) or a spreading out of the current into the sense arms of the X .

COMSOL's Piezoresistivity interfaces solve Equation 3 and an inverse form of Equation 4, together with the equations of structural mechanics. In this model the Piezoresistivity, Boundary Currents interface is used to model the structural equations on the domain level and to solve the electrical equations on a thin layer coincident with a boundary in the model geometry.

## Results and Discussion

Figure 2 shows the displacement of the diaphragm as a result of a 100 kPa pressure difference. At the center of the diaphragm the displacement is $1.2 \mu \mathrm{~m}$. A simple isotropic model for the deform displacement given in Ref. 1 predicts an order of magnitude value of $4 \mu \mathrm{~m}$ (assuming a Young's modulus of 170 GPa and a Poisson's ratio of 0.06 ). The agreement is reasonable considering the limitations of the analytic model, which is derived by a crude variational guess. A more accurate value for the shear stress in local coordinates at the midpoint of the diaphragm edge is given in Ref. 1 as:

$$
\sigma^{l, 12}=0,141\left(\frac{L}{H}\right)^{2} P
$$

where $P$ is the applied pressure, $L$ is the length of the diaphragm edge, and $H$ is the diaphragm thickness. This equation predicts the magnitude of the local shear stress to be 35 MPa , in good agreement with the minimum value shown in Figure 3, which is also 35 MPa . Theoretically the shear stress should be maximal at the midpoint of the edge of the diaphragm. Figure 4 shows the shear stress along the edge in the model. This shows a maximum magnitude at the center of each of the two edges along which the plot is made, but the value of this maximum is less than the maximum stress in the model, in part due to the boundary conditions employed on the three dimensional diaphragm. The model:
piezoresistive_pressure_sensor_shell.mph shows better agreement with the theoretical maximum shear stress along this edge.

Surface: Total displacement ( $\mu \mathrm{m}$ )


Figure 2: Diaphragm displacement as a result of a 100 kPa applied pressure.
Surface: Stress tensor, local coordinate system, 12 component ( $\mathrm{N} / \mathrm{m}^{2}$ )


Figure 3: Shear stress, shown in the local co-ordinate system of the piezoresistor (rotated $45^{\circ}$ about the z-axis of the global system). The shear stress is has its highest magnitude close to the piezoresistor with a value of approximately - 35 MPa.


Figure 4: Plot of the local shear stress along two edges of the diaphragm.
The output of the model during normal operation shows good agreement with the manufacturer's data sheet, given that the device dimensions and doping levels have been guessed. With an applied bias of 3 V a typical operating current of 5.9 mA is obtained (compare the current quoted in Ref. 2 of 6 mA ). The model produces an output voltage of 52 mV , similar to the actual device output of 60 mV quoted in Ref. 2. The detailed current and voltage distribution within the Xducer ${ }^{\mathrm{TM}}$ is shown in Figure 5. There is clear evidence of the current flow "spreading out" into the sense electrodes (which are narrower), a phenomena described in Ref. 3 as the "short circuit" effect. The asymmetry in the potential, which is induced by the piezoresistive effect, is also apparent in the figure.


Figure 5: Arrows: Current density, Contours: Electric Potential, for a device driven by a 3 V bias with an applied pressure of 100 kPa .

## References

1. S.D. Senturia, "A Piezoresistive Pressure Sensor," Microsystem Design, chapter 18, Springer, 2000.
2. Motorola Semiconductor MPX100 series technical data, document: MPX100/D, 1998 (available from Freescale Semiconductor Inc at http://www.freescale.com).
3. M. Bao, Analysis and Design Principles of MEMS Devices, Elsevier B. V., 2005.

Application Library path: MEMS_Module/Sensors/
piezoresistive_pressure_sensor

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Piezoresistivity>Piezoresistivity, Boundary Currents.

3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces>Stationary.
6 Click Done.

## GEOMETRY I

I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
For convenience, the device geometry is inserted from an existing file. You can read the instructions for creating the geometry in the .

4 On the Geometry toolbar, click Insert Sequence.
5 Browse to the model's Application Libraries folder and double-click the file piezoresistive_pressure_sensor_geom_sequence.mph.

6 On the Geometry toolbar, click Build AlI.

## DEFINITIONS

## Explicit I

I On the Definitions toolbar, click Explicit.
2 In the Settings window for Explicit, type Piezoresistor in the Label text field.
3 Locate the Input Entities section. From the Geometric entity level list, choose Boundary.
4 Select Boundary 46 only.

## Explicit 2

I On the Definitions toolbar, click Explicit.
2 In the Settings window for Explicit, type Connections in the Label text field.
3 Locate the Input Entities section. From the Geometric entity level list, choose Boundary.
4 Select Boundaries 14, 22, 26, 39, 46, 73, 77, 81, and 104 only.

Box I
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, type Membrane (Lower Surface) in the Label text field.

3 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
4 Locate the Box Limits section. In the $\mathbf{x}$ minimum text field, type -501.
5 In the $\mathbf{x}$ maximum text field, type 501.
6 In the y minimum text field, type - 30 .
7 In the y maximum text field, type 1000.
8 In the $\mathbf{z}$ maximum text field, type -1.
9 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

## Membrane (Lower Surface) I

I Right-click Membrane (Lower Surface) and choose Duplicate.
2 In the Settings window for Box, type Membrane (Upper Surface) in the Label text field.

3 Locate the Box Limits section. In the $\mathbf{z}$ minimum text field, type -1.
4 In the $\mathbf{z}$ maximum text field, type inf.
Box 3
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, type Lower Surface in the Label text field.
3 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
4 Locate the Box Limits section. In the $\mathbf{z}$ maximum text field, type - 1 .
5 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

## Lower Surface I

I Right-click Lower Surface and choose Duplicate.
2 In the Settings window for Box, type Upper Surface in the Label text field.
3 Locate the Box Limits section. In the $\mathbf{z}$ minimum text field, type -1 .
4 In the $\mathbf{z}$ maximum text field, type inf.
Difference I
I On the Definitions toolbar, click Difference.

2 In the Settings window for Difference, type Fixed in the Label text field.
3 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
4 Locate the Input Entities section. Under Selections to add, click Add.
5 In the Add dialog box, select Lower Surface in the Selections to add list.
6 Click OK.
7 In the Settings window for Difference, locate the Input Entities section.
8 Under Selections to subtract, click Add.
9 In the Add dialog box, select Membrane (Lower Surface) in the Selections to subtract list.
IO Click OK.

## Union I

I On the Definitions toolbar, click Union.
2 In the Settings window for Union, type Electric Currents in the Label text field.
3 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
4 Locate the Input Entities section. Under Selections to add, click Add.
5 In the Add dialog box, In the Selections to add list, choose Piezoresistor and Connections.
6 Click OK.
Rotated System 2 (sys2)
I On the Definitions toolbar, click Coordinate Systems and choose Rotated System.
2 In the Settings window for Rotated System, locate the Settings section.
3 Find the Euler angles (Z-X-Z) subsection. In the $\alpha$ text field, type -45[deg].

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select Piezoresistivity>n-Silicon (single-crystal, lightly doped).
4 Click Add to Component I.

## ADD MATERIAL

I Go to the Add Material window.
2 In the tree, select Piezoresistivity>p-Silicon (single-crystal, lightly doped).
3 Click Add to Component I.

## MATERIALS

p-Silicon (single-crystal, lightly doped) (mat2)
I On the Home toolbar, click Add Material to close the Add Material window.
2 In the Model Builder window, under Component I (compl)>Materials click pSilicon (single-crystal, lightly doped) (mat2).

3 In the Settings window for Material, locate the Geometric Entity Selection section.
4 From the Geometric entity level list, choose Boundary.
5 From the Selection list, choose Electric Currents.

## SOLID MECHANICS (SOLID)

## Linear Elastic Material I

I In the Model Builder window, under Component I (comp I)>Solid Mechanics (solid) click Linear Elastic Material I.

2 In the Settings window for Linear Elastic Material, locate the Coordinate System Selection section.

3 From the Coordinate system list, choose Rotated System 2 (sys2).
4 Locate the Linear Elastic Material section. From the Solid model list, choose Anisotropic.
5 From the Material data ordering list, choose Voigt (XX, YY, ZZ, YZ, XZ, XY).

## Fixed Constraint I

I In the Model Builder window, right-click Solid Mechanics (solid) and choose Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.
3 From the Selection list, choose Fixed.

## Boundary Load I

I Right-click Solid Mechanics (solid) and choose Boundary Load.
2 In the Settings window for Boundary Load, locate the Boundary Selection section.
3 From the Selection list, choose Membrane (Upper Surface).
4 Locate the Force section. From the Load type list, choose Pressure.
5 In the $p$ text field, type 100 [kPa].

ELECTRIC CURRENTS, SHELL (ECS)
I In the Model Builder window, under Component I (compl) click Electric Currents, Shell (ecs).

2 In the Settings window for Electric Currents, Shell, locate the Boundary Selection section.
3 From the Selection list, choose Electric Currents.
4 Locate the Shell Thickness section. In the $d_{s}$ text field, type $400[\mathrm{~nm}]$.

## Current Conservation I

I In the Model Builder window, under Component I (compl)>Electric Currents, Shell (ecs) click Current Conservation I.

2 In the Settings window for Current Conservation, locate the Model Inputs section.
3 In the $n_{d}$ text field, type $1.45 \mathrm{e} 20[1 / \mathrm{cm} \wedge 3]$.
4 Locate the Coordinate System Selection section. From the Coordinate system list, choose Rotated System 2 (sys2).

## Piezoresistive Material I

I In the Model Builder window, under Component I (compl)>Electric Currents, Shell (ecs) click Piezoresistive Material I.

2 In the Settings window for Piezoresistive Material, locate the Boundary Selection section.
3 From the Selection list, choose Piezoresistor.
4 Locate the Model Input section. In the $n_{d}$ text field, type $1.32 \mathrm{e} 19\left[1 / \mathrm{cm}^{\wedge} 3\right]$.
5 Locate the Coordinate System Selection section. From the Coordinate system list, choose Rotated System 2 (sys2).

## Ground I

I In the Model Builder window, right-click Electric Currents, Shell (ecs) and choose Ground.
2 Select Edge 195 only.

## Terminal I

I Right-click Electric Currents, Shell (ecs) and choose Terminal.
2 Select Edges 30 and 35 only.
3 In the Settings window for Terminal, locate the Terminal section.
4 From the Terminal type list, choose Voltage.
5 In the $V_{0}$ text field, type 3.

## Terminal 2

I Right-click Electric Currents, Shell (ecs) and choose Terminal.
2 Select Edge 20 only.

## Terminal 3

I Right-click Electric Currents, Shell (ecs) and choose Terminal.

2 Select Edges 201 and 205 only.

## MESH I

I In the Model Builder window, under Component I (compl) click Mesh I.
2 In the Settings window for Mesh, locate the Mesh Settings section.
3 From the Sequence type list, choose User-controlled mesh.
Size
I In the Model Builder window, under Component I (compl)>Mesh I click Size.
2 In the Settings window for Size, locate the Element Size section.
3 Click the Custom button.
4 Locate the Element Size Parameters section. In the Maximum element size text field, type 60.

5 In the Minimum element size text field, type 0.5.
Size I
I In the Model Builder window, right-click Mesh I and choose Size.
2 In the Settings window for Size, locate the Geometric Entity Selection section.
3 From the Geometric entity level list, choose Boundary.
4 From the Selection list, choose Piezoresistor.
5 Locate the Element Size section. Click the Custom button.
6 Locate the Element Size Parameters section. Select the Maximum element size check box.
7 In the associated text field, type 2.
8 Select the Minimum element size check box.
9 In the associated text field, type 0.1.
Size 2
I Right-click Component I (compI)>Mesh I>Size I and choose Duplicate.
2 In the Settings window for Size, locate the Geometric Entity Selection section.
3 From the Selection list, choose Connections.
4 Locate the Element Size Parameters section. In the Maximum element size text field, type 6.

Size 3
I Right-click Component I (compI)>Mesh I>Size 2 and choose Duplicate.
2 In the Settings window for Size, locate the Geometric Entity Selection section.

3 From the Geometric entity level list, choose Edge.
4 Click the Select Box button on the Graphics toolbar.
5 Select Edges $74,79,104,108,111,114,117,120,123,142,143$, and 146 only.
6 Locate the Element Size Parameters section. In the Maximum element size text field, type 0.4 .

## Free Tetrahedral I

In the Model Builder window, under Component I (compI)>Mesh I right-click Free Tetrahedral I and choose Disable.

## Free Triangular I

I Right-click Mesh I and choose More Operations>Free Triangular.
2 In the Settings window for Free Triangular, locate the Boundary Selection section.
3 From the Selection list, choose Upper Surface.

## Swept I

I Right-click Mesh I and choose Swept.
2 On the Home toolbar, click Build Mesh.
3 Click Compute.

## RESULTS

## Stress (solid)

The default plots show the von Mises stress and the electric potential. Now create a plot of the total displacement to compare with .

## 3D Plot Group 3

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Settings window for 3D Plot Group, type Displacement in the Label text field.

## Surface I

I Right-click Displacement and choose Surface.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>solid.disp - Total displacement.

## Deformation I

I Right-click Results>Displacement>Surface I and choose Deformation.

2 On the Displacement toolbar, click Plot.
Now create a plot of the shear stress in the local coordinate system of the piezoresistor, to compare with .

## 3D Plot Group 4

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Settings window for 3D Plot Group, type In-Plane Shear Stress (Local Coordinates) in the Label text field.

## Surface I

I Right-click In-Plane Shear Stress (Local Coordinates) and choose Surface.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics>Stress> Stress tensor, local coordinate system>solid.sll2-Stress tensor, local coordinate system, 12 component.

3 On the In-Plane Shear Stress (Local Coordinates) toolbar, click Plot.
Create a line plot of the shear stress in the local coordinate system of the piezoresistor, to compare with .

## ID Plot Group 5

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, type In-Plane Shear Stress (Local Coordinate System) in the Label text field.

## Line Graph I

I Right-click In-Plane Shear Stress (Local Coordinate System) and choose Line Graph.
2 Select Edges 16 and 213 only.
3 In the Settings window for Line Graph, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I>Solid Mechanics>Stress> Second Piola-Kirchhoff stress, local coordinate system>solid.SII2-Second PiolaKirchhoff stress, local coordinate system, 12 component.
4 On the In-Plane Shear Stress (Local Coordinate System) toolbar, click Plot.
Now create a plot of the detailed current and voltage distribution, to compare with .
Study I/Solution I (soll)
In the Model Builder window, expand the Results>Data Sets node.

## Selection

I Right-click Study I/Solution I (soll) and choose Duplicate.

2 On the Results toolbar, click Selection.
3 In the Settings window for Selection, locate the Geometric Entity Selection section.
4 From the Geometric entity level list, choose Boundary.
5 From the Selection list, choose Piezoresistor.
6 Click Zoom to Selection.
7 From the Selection list, choose Electric Currents.

## 3D Plot Group 6

I On the Results toolbar, click 3D Plot Group.
2 In the Settings window for 3D Plot Group, type Current and Voltage in the Label text field.

3 Locate the Data section. From the Data set list, choose Study I/Solution I (2) (soll).

## Contour I

I Right-click Current and Voltage and choose Contour.
2 In the Settings window for Contour, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Electric Currents, Shell> Electric $>V$ - Electric potential.

3 Locate the Levels section. In the Total levels text field, type 40.
4 Locate the Coloring and Style section. From the Color table list, choose Thermal.
5 Select the Reverse color table check box.

## Arrow Surface I

I In the Model Builder window, under Results right-click Current and Voltage and choose Arrow Surface.

2 In the Settings window for Arrow Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Electric Currents, Shell>Currents and charge>ecs.tJX,...,ecs.tJZ Tangential current density (material and geometry frames).

3 Locate the Coloring and Style section. Select the Scale factor check box.
4 In the associated text field, type 2e-9.
5 In the Number of arrows text field, type 3000.
6 From the Color list, choose Blue.
7 On the Current and Voltage toolbar, click Plot.
Finally evaluate the current drawn by the device and the output voltage.

## Global Evaluation I

I On the Results toolbar, click Global Evaluation.
2 In the Settings window for Global Evaluation, click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Component I> Electric Currents, Shell>Terminals>ecs.IO_I - Terminal current.

3 Click Add Expression in the upper-right corner of the Expressions section. From the menu, choose Component I>Electric Currents, Shell>Terminals>ecs.V0_2-
Terminal voltage.
4 Locate the Expressions section. In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| ecs.IO_1 | mA | Terminal current |
| ecs.VO_2-ecs.V0_3 | mV | Device Output |

5 Click Evaluate.

## Piezoresistive Pressure Sensor, Shell

## Introduction

Piezoresistive pressure sensors were some of the first MEMS devices to be commercialized.
Compared to capacitive pressure sensors, they are simpler to integrate with electronics, their response is more linear and they are inherently shielded from RF noise. They do, however, usually require more power during operation and the fundamental noise limits of the sensor are higher than their capacitive counterparts. Historically, piezoresistive devices have been dominant in the pressure sensor market.

This example considers the design of the MPX100 series pressure sensors originally manufactured by Motorola Inc. (now Freescale Semiconductor, Inc.). Although the sensor is no longer in production, a detailed analysis of its design is given in Ref. 1, and an archived data sheet is available from Freescale Semiconductor Inc. (Ref. 2).

Note: This model requires the MEMS Module and the Structural Mechanics Module.

## Model Definition

The model consists square membrane with side 1 mm and thickness $20 \mu \mathrm{~m}$, supported around its edges by region 0.1 mm wide, which is intended to represent the remainder of the wafer. The supporting region is fixed on its underside (representing a connection to the thicker handle of the device die). Near to one edge of the membrane an X -shaped piezoresistor (or $\left.\mathrm{Xducer}{ }^{\mathrm{TM}}\right)^{1}$ and part of its associated interconnects are visible. The geometry is shown in Figure 1.
The piezoresistor is assumed to have a uniform p-type dopant density of $1.32 \times 10^{19} \mathrm{~cm}^{-3}$ and a thickness of 400 nm . The interconnects are assumed to have the same thickness but a dopant density of $1.45 \times 10^{20} \mathrm{~cm}^{-3}$. Only a part of the interconnects is included in the geometry, since their conductivity is sufficiently high that they do not contribute to the voltage output of the device (in practice the interconnects would also be thicker in addition to having a higher conductivity but this also has little effect on the solution).

The edges of the die are aligned with the $\{110\}$ directions of the silicon. The die edges are also aligned with the global $X$ - and $Y$-axes in the COMSOL model. The piezoresistor is oriented at 45 to the die edge, and so lies in the [100] direction of the crystal. In the

[^1]COMSOL model, a co-ordinate system rotated 45 about the global $Z$-axis is added to define the orientation of the crystal.


Figure 1: Left: Model geometry. Right: Detail showing the piezoresistor geometry.

## DEVICE PHYSICS AND EQUATIONS

The conductivity of the Xducer ${ }^{\mathrm{TM}}$ sensor changes when the membrane in its vicinity is subject to an applied stress. This effect is known as the piezoresistance effect and is usually associated with semiconducting materials. In semiconductors, piezoresistance results from the strain induced alteration of the material's band structure, and the associated changes in carrier mobility and number density. The relation between the electric field, $\mathbf{E}$, and the current, $\boldsymbol{J}$, within a piezoresistor is:

$$
\begin{equation*}
\mathbf{E}=\rho \cdot \mathbf{J}+\Delta \rho \cdot \mathbf{J} \tag{1}
\end{equation*}
$$

where $\rho$ is the resistivity and $\Delta \rho$ is the induced change in the resistivity. In the general case both $\rho$ and $\Delta \rho$ are rank 2 tensors (matrices). The change in resistance is related to the stress, $\sigma$, by the constitutive relationship:

$$
\begin{equation*}
\Delta \rho=\Pi \cdot \sigma \tag{2}
\end{equation*}
$$

where $\Pi$ is the piezoresistance tensor (SI units: $\mathrm{Pa}^{-1} \Omega \mathrm{~m}$ ), a material property. Note that COMSOL's definition of $\Pi$ includes the resistivity in each element of the tensor, rather than having a scalar multiple outside of $\Pi$ (which is possible only for materials with isotropic conductivity). $\Pi$ is in this case a rank 4 tensors, however it can be represented as a matrix if the resistivity and stress are converted to vectors within a reduced subscript notation. Within the Voigt notation employed by COMSOL for this purpose, Equation 2 becomes:

$$
\left[\begin{array}{c}
\Delta \rho_{x x}  \tag{3}\\
\Delta \rho_{y y} \\
\Delta \rho_{z z} \\
\Delta \rho_{y z} \\
\Delta \rho_{x z} \\
\Delta \rho_{x y}
\end{array}\right]=\left[\begin{array}{llllll}
\Pi_{11} & \Pi_{12} & \Pi_{13} & \Pi_{14} & \Pi_{15} & \Pi_{16} \\
\Pi_{21} & \Pi_{22} & \Pi_{23} & \Pi_{24} & \Pi_{25} & \Pi_{26} \\
\Pi_{31} & \Pi_{32} & \Pi_{33} & \Pi_{34} & \Pi_{35} & \Pi_{36} \\
\Pi_{41} & \Pi_{42} & \Pi_{43} & \Pi_{44} & \Pi_{45} & \Pi_{46} \\
\Pi_{51} & \Pi_{52} & \Pi_{53} & \Pi_{54} & \Pi_{55} & \Pi_{56} \\
\Pi_{61} & \Pi_{62} & \Pi_{63} & \Pi_{64} & \Pi_{65} & \Pi_{66}
\end{array}\right] \cdot\left[\begin{array}{c}
\sigma^{x x} \\
\sigma^{y y} \\
\sigma^{z z} \\
\sigma^{y z} \\
\sigma^{x z} \\
\sigma^{x y}
\end{array}\right]
$$

The $\Delta \rho$ vector computed from Equation 3 is assembled into matrix form in the following manner in Equation 1:

$$
\left[\begin{array}{c}
E_{x}  \tag{4}\\
E_{y} \\
E_{z}
\end{array}\right]=\left[\begin{array}{lll}
\rho_{x x} & \rho_{x y} & \rho_{x z} \\
\rho_{x y} & \rho_{y y} & \rho_{y z} \\
\rho_{x z} & \rho_{y z} & \rho_{z z}
\end{array}\right] \cdot\left[\begin{array}{c}
J_{x} \\
J_{y} \\
J_{z}
\end{array}\right]+\left[\begin{array}{ccc}
\Delta \rho_{x x} & \Delta \rho_{x y} & \Delta \rho_{x z} \\
\Delta \rho_{x y} & \Delta \rho_{y y} & \Delta \rho_{y z} \\
\Delta \rho_{x z} & \Delta \rho_{y z} & \Delta \rho_{z z}
\end{array}\right] \cdot\left[\begin{array}{c}
J_{x} \\
J_{y} \\
J_{z}
\end{array}\right]
$$

Silicon has cubic symmetry, and as a result the $\Pi$ matrix can be described in terms of three independent constants in the following manner:

$$
\Pi=\left[\begin{array}{cccccc}
\Pi_{11} & \Pi_{12} & \Pi_{12} & 0 & 0 & 0 \\
\Pi_{12} & \Pi_{22} & \Pi_{12} & 0 & 0 & 0 \\
\Pi_{12} & \Pi_{12} & \Pi_{33} & 0 & 0 & 0 \\
0 & 0 & 0 & \Pi_{44} & 0 & 0 \\
0 & 0 & 0 & 0 & \Pi_{44} & 0 \\
0 & 0 & 0 & 0 & 0 & \Pi_{44}
\end{array}\right]
$$

For p-type silicon the $\Pi_{44}$ constant is two orders of magnitude larger than either the $\Pi_{11}$ or the $\Pi_{12}$ coefficients. The $\Pi_{66}$ element (which is equal in magnitude to the $\Pi_{44}$ element) couples the $\sigma_{x y}$ shear stress, with the $\Delta \rho_{x y}$ off-diagonal term in the change in resistivity matrix. In turn, $\Delta \rho_{x y}$ couples a current in the $x$-direction to an induced electric field in the $y$-direction (and vice versa). This is the principle of the Xducer ${ }^{\mathrm{TM}}$ transducer. An applied voltage (typically 3 V (Ref. 2)) across the [100] orientated arm of the X produces a current (typically 6 mA (Ref. 2)) down this arm. Shear stresses are present in the Xducer ${ }^{\text {TM }}$ as a result of the pressure induced deformation of the diaphragm in which it is implanted. Through the piezoresistance effect, these shear stresses cause an electric field or potential gradient transverse to the direction of current flow, in the [010] arm of the X. Across the
width of the transducer, the potential gradient sums up to produce an induced voltage difference between the [010] arms of the X. According to the device data sheet, under normal operating conditions a 60 mV potential difference is generated from a 100 kPa applied pressure with a 3 V applied bias (Ref. 2)).

The situation is complicated somewhat by the detailed current distribution within the device, since the voltage sensing elements increase the width of the current carrying silicon wire locally, leading to a "short circuit" effect (Ref. 3) or a spreading out of the current into the sense arms of the X .

COMSOL's Piezoresistance interfaces solve Equation 3 and an inverse form of Equation 4, together with the equations of structural mechanics. In this model the Piezoresistance, Boundary Currents interface is used to model the structural equations on the domain level and to solve the electrical equations on a thin layer coincident with a boundary in the model geometry.

## Results and Discussion

Figure 2 shows the displacement of the diaphragm as a result of a 100 kPa pressure difference applied to the membrane, at its center the displacement is $1.2 \mu \mathrm{~m}$. A simple isotropic model for the deform displacement given in Ref. 1 predicts an order of magnitude value for the displacement of $4 \mu \mathrm{~m}$ (assuming a Young's Modulus of 170 GPa and a Poisson's ratio of 0.06 ). The agreement is reasonable considering the limitations of the analytic model, which is derived by a crude variational guess. A more accurate value for the shear stress in local co-ordinates at the midpoint of the diaphragm edge is given in Ref. 1 as:

$$
\sigma^{l, 12}=0,141\left(\frac{L}{H}\right)^{2} P
$$

where P is the applied pressure, L is the length of the diaphragm edge and H is the diaphragm thickness. This equation predicts the magnitude of the local shear stress to be 35 MPa , in good agreement with the minimum value shown in Figure 3, which is 35 MPa . Theoretically the shear stress should be maximal at the mid point of the edge of the diaphragm. Figure 4 shows the shear stress along the edge in the model. This shows a maximum magnitude of 38 MPa at the center of each of the two edges along which the plot is made.

Surface: Total displacement ( $\mu \mathrm{m}$ )


Figure 2: Diaphragm displacement as a result of a 100 kPa applied pressure.

Surface: Second Piola-Kirchhoff stress, local coordinate system, 12 component ( $\mathrm{N} / \mathrm{m}^{2}$ ) $\mathrm{xx} / \mathrm{Min}$ Surface: Second Piola-Kirchhoff stress, local coordinate system, 12 component ( $\mathrm{N} / \mathrm{I}$


Figure 3: Shear stress, shown in the local co-ordinate system of the piezoresistor (rotated $45^{\circ}$ about the z-axis of the global system). The shear stress is has its highest magnitude close to the piezoresistor with a value of approximately -35 MPa.


Figure 4: Plot of the local shear stress along two edges of the diaphragm.
The output of the model during normal operation shows good agreement with the manufacturer's data sheet, given that the device dimensions and doping levels have been guessed. With an applied bias of 3 V a typical operating current of 5.9 mA is obtained (c.f. the current quoted in Ref. 2 of 6 mA ). The model produces an output voltage of 54 mV , similar to the actual device output of 60 mV quoted in Ref. 2. The detailed current and voltage distribution within the $\mathrm{Xducer}{ }^{\mathrm{TM}}$ is shown in Figure 5. There is clear evidence of the current flow 'spreading out' into the sense electrodes (which are narrower), a phenomena described in Ref. 3 as the 'short circuit' effect. The asymmetry in the potential, which is induced by the piezoresistive effect, is also apparent in the figure.


Figure 5: Arrows: Current density, Contours: Electric Potential, for a device driven by a 3 V bias with an applied pressure of 100 kPa .

## References

1. S.D. Senturia, "A Piezoresistive Pressure Sensor," Microsystem Design, chapter 18, Springer, 2000.
2. Motorola Semiconductor MPX100 series technical data, document: MPX100/D, 1998 (available from Freescale Semiconductor, Inc at http://www.freescale.com).
3. M. Bao, Analysis and Design Principles of MEMS Devices, Elsevier B. V., 2005.

Application Library path: MEMS_Module/Sensors/
piezoresistive_pressure_sensor_shell

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Piezoresistivity>Piezoresistivity, Shell.

3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces>Stationary.
6 Click Done.

## GEOMETRY I

I In the Model Builder window, click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu} \mathbf{m}$.
For convenience, the device geometry is inserted from an existing file. You can read the instructions for creating the geometry in the .

4 On the Geometry toolbar, click Insert Sequence.
5 Browse to the model's Application Libraries folder and double-click the file piezoresistive_pressure_sensor_shell_geom_sequence.mph.

6 On the Geometry toolbar, click Build All.
The dimensions of this geometry are given in micrometers, so you need to change the length unit accordingly.

## DEFINITIONS

## Explicit I

I On the Definitions toolbar, click Explicit.
2 In the Settings window for Explicit, type Piezoresistor in the Label text field.
3 Locate the Input Entities section. From the Geometric entity level list, choose Boundary.
4 Select Boundary 9 only.

## Piezoresistor I

I Right-click Piezoresistor and choose Duplicate.
2 In the Settings window for Explicit, type Connections in the Label text field.

3 Locate the Input Entities section. Click Clear Selection.
4 Select Boundaries $3,5,6,8,13-15$, and 18 only.
Box 1
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, type Membrane in the Label text field.
3 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
4 Locate the Box Limits section. In the $\mathbf{x}$ minimum text field, type -501.
5 In the $\mathbf{x}$ maximum text field, type 501.
6 In the y minimum text field, type - 30 .
7 In the y maximum text field, type 1000.
8 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

## Union I

I On the Definitions toolbar, click Union.
2 In the Settings window for Union, type Model boundaries in the Label text field.
3 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
4 Locate the Input Entities section. Under Selections to add, click Add.
5 In the Add dialog box, In the Selections to add list, choose Connections and Membrane.
6 Click OK.

## Model boundaries I

I Right-click Model boundaries and choose Duplicate.
2 In the Settings window for Union, type Electric currents in the Label text field.
3 Locate the Input Entities section. In the Selections to add list, select Membrane.
4 Under Selections to add, click Delete.
5 Under Selections to add, click Add.
6 In the Add dialog box, select Piezoresistor in the Selections to add list.
7 Click OK.
Adjacent I
I On the Definitions toolbar, click Adjacent.
2 In the Settings window for Adjacent, type Fixed Edges in the Label text field.
3 Locate the Input Entities section. From the Geometric entity level list, choose Boundary.

4 Under Input selections, click Add.
5 In the Add dialog box, select Membrane in the Input selections list.
6 Click OK.
7 In the Settings window for Adjacent, locate the Output Entities section.
8 From the Geometric entity level list, choose Adjacent edges.

## Difference I

I On the Definitions toolbar, click Difference.
2 In the Settings window for Difference, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.
4 Locate the Input Entities section. Under Selections to add, click Add.
5 In the Add dialog box, select Model boundaries in the Selections to add list.
6 Click OK.
7 In the Settings window for Difference, locate the Input Entities section.
8 Under Selections to subtract, click Add.
9 In the Add dialog box, select Membrane in the Selections to subtract list.
$\mathbf{I O}$ Click OK.
II In the Settings window for Difference, type Fixed Boundaries in the Label text field.

## Rotated System 2 (sys2)

I On the Definitions toolbar, click Coordinate Systems and choose Rotated System.
2 In the Settings window for Rotated System, locate the Settings section.
3 Find the Euler angles (Z-X-Z) subsection. In the $\alpha$ text field, type -45[deg].

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select Piezoresistivity>n-Silicon (single-crystal, lightly doped).
4 Click Add to Component in the window toolbar.

## ADD MATERIAL

I Go to the Add Material window.
2 In the tree, select Piezoresistivity>p-Silicon (single-crystal, lightly doped).
3 Click Add to Component in the window toolbar.

4 On the Home toolbar, click Add Material to close the Add Material window.

## MATERIALS

p-Silicon (single-crystal, lightly doped) (mat2)
I In the Model Builder window, under Component I (compl)>Materials click pSilicon (single-crystal, lightly doped) (mat2).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Electric currents.

## SHELL (SHELL)

I In the Model Builder window, under Component I (compl) click Shell (shell).
2 In the Settings window for Shell, locate the Boundary Selection section.
3 From the Selection list, choose Model boundaries.
4 Locate the Thickness section. In the $d$ text field, type 20 [um].

## Linear Elastic Material I

I In the Model Builder window, under Component I (compl)>Shell (shell) click Linear Elastic Material I.

2 In the Settings window for Linear Elastic Material, locate the Linear Elastic Material section.

3 From the Solid model list, choose Anisotropic.
4 From the Material data ordering list, choose Voigt (XX, YY, ZZ, YZ, XZ, XY).

## Shell Local System I

I In the Model Builder window, expand the Linear Elastic Material I node, then click Shell Local System I.

2 In the Settings window for Shell Local System, locate the Coordinate System Selection section.

3 From the Coordinate system list, choose Rotated System 2 (sys2).

## Fixed Constraint I

I In the Model Builder window, right-click Shell (shell) and choose Fixed Constraint.
2 In the Settings window for Fixed Constraint, locate the Edge Selection section.
3 From the Selection list, choose Fixed Edges.
Fixed Constraint 2
I Right-click Shell (shell) and choose Face Constraints>Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.
3 From the Selection list, choose Fixed Boundaries.
Face Load I
I Right-click Shell (shell) and choose Face and Volume Loads>Face Load.
2 In the Settings window for Face Load, locate the Boundary Selection section.
3 From the Selection list, choose Membrane.
4 Locate the Force section. From the Load type list, choose Pressure.
5 In the $p$ text field, type 100 [ kPa ].

## ELECTRIC CURRENTS, SHELL (ECS)

I In the Model Builder window, under Component I (compl) click Electric Currents, Shell (ecs).
2 In the Settings window for Electric Currents, Shell, locate the Boundary Selection section.
3 Click Clear Selection.
4 From the Selection list, choose Electric currents.
5 Locate the Shell Thickness section. In the $d_{s}$ text field, type 0.4 [um].

## Current Conservation I

I In the Model Builder window, under Component I (compl)>Electric Currents, Shell (ecs) click Current Conservation I.

2 In the Settings window for Current Conservation, locate the Model Inputs section.
3 In the $n_{d}$ text field, type $1.45 \mathrm{e} 20\left[1 / \mathrm{cm}^{\wedge} 3\right]$.
4 Locate the Coordinate System Selection section. From the Coordinate system list, choose Rotated System 2 (sys2).

## Piezoresistive Material I

I In the Model Builder window, under Component I (compl)>Electric Currents, Shell (ecs) click Piezoresistive Material I.

2 In the Settings window for Piezoresistive Material, locate the Boundary Selection section.
3 From the Selection list, choose Piezoresistor.
4 Locate the Model Input section. In the $n_{d}$ text field, type $1.32 \mathrm{e} 19\left[1 / \mathrm{cm}^{\wedge} 3\right]$.
5 Locate the Coordinate System Selection section. From the Coordinate system list, choose Rotated System 2 (sys2).

## Ground I

I In the Model Builder window, right-click Electric Currents, Shell (ecs) and choose Ground.

2 Select Edge 70 only.

## Terminal I

I Right-click Electric Currents, Shell (ecs) and choose Terminal.
2 Select Edges 11 and 13 only.
3 In the Settings window for Terminal, locate the Terminal section.
4 From the Terminal type list, choose Voltage.
5 In the $V_{0}$ text field, type 3.

## Terminal 2

I Right-click Electric Currents, Shell (ecs) and choose Terminal.
2 Select Edge 7 only.

## Terminal 3

I Right-click Electric Currents, Shell (ecs) and choose Terminal.
2 Select Edges 72 and 73 only.

## MESH I

I In the Model Builder window, under Component I (compl) click Mesh I.
2 In the Settings window for Mesh, locate the Mesh Settings section.
3 From the Sequence type list, choose User-controlled mesh.
Size
I In the Model Builder window, under Component I (compl)>Mesh I click Size.
2 In the Settings window for Size, locate the Element Size section.
3 Click the Custom button.
4 Locate the Element Size Parameters section. In the Maximum element size text field, type 60.

5 In the Minimum element size text field, type 0.5.
Size 1
I Right-click Component I (compl)>Mesh I>Size and choose Duplicate.
2 In the Settings window for Size, locate the Geometric Entity Selection section.
3 From the Geometric entity level list, choose Boundary.
4 From the Selection list, choose Piezoresistor.
5 Locate the Element Size Parameters section. In the Maximum element size text field, type 2.

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6 In the Minimum element size text field, type 0.1.
Size 2
I Right-click Component I (compI)>Mesh I>Size I and choose Duplicate.
2 In the Settings window for Size, locate the Geometric Entity Selection section.
3 From the Selection list, choose Connections.
4 Locate the Element Size Parameters section. In the Maximum element size text field, type 6.

## Size 3

I Right-click Component I (compl)>Mesh I>Size 2 and choose Duplicate.
2 In the Settings window for Size, locate the Geometric Entity Selection section.
3 From the Geometric entity level list, choose Edge.
4 Select Edges 27, 29, 38-44, and 51-53 only.
5 Locate the Element Size Parameters section. In the Maximum element size text field, type 0.4 .

## Free Triangular I

I In the Model Builder window, under Component I (compI)>Mesh I right-click Free Triangular I and choose Move Down.

2 Right-click Component I (compl)>Mesh I>Free Triangular I and choose Move Down.
3 Right-click Component I (compI)>Mesh I>Free Triangular I and choose Move Down.
4 On the Home toolbar, click Compute.

## RESULTS

## Stress (shell)

The default plots show the von Mises stress, the undeformed geometry and the electric potential. Now create a plot of the total displacement to compare with .

Study I/Solution I (soll)
In the Model Builder window, expand the Results>Data Sets node.

## Selection

I Right-click Study I/Solution I (solI) and choose Duplicate.
2 On the Results toolbar, click Selection.
3 In the Settings window for Selection, locate the Geometric Entity Selection section.
4 From the Geometric entity level list, choose Boundary.

## 5 From the Selection list, choose Membrane.

## 3D Plot Group 5

I On the Results toolbar, click 3D Plot Group.
2 In the Settings window for 3D Plot Group, type Displacement in the Label text field.
3 Locate the Data section. From the Data set list, choose Study I/Solution I (2) (soll).

## Surface I

I Right-click Displacement and choose Surface.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Model>Component I>Shell> Displacement>shell.disp - Total displacement.

## Deformation I

I Right-click Results>Displacement>Surface I and choose Deformation.
2 On the Displacement toolbar, click Plot.
Now create a plot of the shear stress in the local coordinate system of the piezoresistor, to compare with .

## 3D Plot Group 6

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Settings window for 3D Plot Group, type In-Plane Shear Stress (Local Coordinates) in the Label text field.

3 Locate the Data section. From the Data set list, choose Study I/Solution I (2) (solI).

## Surface I

I Right-click In-Plane Shear Stress (Local Coordinates) and choose Surface.
2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Model>Component I>Shell>Stress> Second Piola-Kirchhoff stress, local coordinate system>shell.SII2 - Second PiolaKirchhoff stress, local coordinate system, 12 component.

## In-Plane Shear Stress (Local Coordinates)

In the Model Builder window, under Results click In-Plane Shear Stress (Local Coordinates).

## Max/Min Surface I

I On the In-Plane Shear Stress (Local Coordinates) toolbar, click More Plots and choose Max/ Min Surface.

2 In the Settings window for Max/Min Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose shell.SII2 - Second PiolaKirchhoff stress, local coordinate system, 12 component.
3 On the In-Plane Shear Stress (Local Coordinates) toolbar, click Plot.
Create a line plot of the shear stress in the local coordinate system of the piezoresistor, to compare with .

## ID Plot Group 7

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, type In-Plane Shear Stress (Local Coordinate System) in the Label text field.

## Line Graph I

I Right-click In-Plane Shear Stress (Local Coordinate System) and choose Line Graph.
2 Select Edges 6 and 76 only.
3 In the Settings window for Line Graph, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Model>Component I>Shell>Stress> Second Piola-Kirchhoff stress, local coordinate system>shell.SII2 - Second PiolaKirchhoff stress, local coordinate system, 12 component.
4 On the In-Plane Shear Stress (Local Coordinate System) toolbar, click Plot.
Now create a plot of the detailed current and voltage distribution, to compare with .

## Selection

I In the Model Builder window, under Results>Data Sets right-click Study I/ Solution I (2) (soll) and choose Duplicate.

2 In the Model Builder window, expand the Study I/Solution I (3) (soll) node, then click Selection.

3 In the Settings window for Selection, locate the Geometric Entity Selection section.
4 From the Selection list, choose Piezoresistor.
5 Click Zoom to Selection.
6 From the Selection list, choose Electric currents.

## 3D Plot Group 8

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Settings window for 3D Plot Group, type Current and Voltage in the Label text field.

3 Locate the Data section. From the Data set list, choose Study I/Solution I (3) (soll).

## Contour 1

I Right-click Current and Voltage and choose Contour.
2 In the Settings window for Contour, locate the Expression section.
3 In the Expression text field, type V.
4 Locate the Levels section. In the Total levels text field, type 40.
5 Locate the Coloring and Style section. From the Color table list, choose Thermal.
6 Select the Reverse color table check box.

## Arrow Surface I

I In the Model Builder window, under Results right-click Current and Voltage and choose Arrow Surface.

2 In the Settings window for Arrow Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Model>Component I> Electric Currents, Shell>Currents and charge>ecs.tJx,...,ecs.tJz - Tangential current density.

3 Locate the Coloring and Style section. Select the Scale factor check box.
4 In the associated text field, type 2e-9.
5 In the Number of arrows text field, type 3000.
6 From the Color list, choose Blue.
7 On the Current and Voltage toolbar, click Plot.
Finally evaluate the current drawn by the device and the output voltage.

## Global Evaluation I

I On the Results toolbar, click Global Evaluation.
2 In the Settings window for Global Evaluation, click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Model>Component I> Electric Currents, Shell>Terminals>ecs.IO_I - Terminal current.

3 Click Add Expression in the upper-right corner of the Expressions section. From the menu, choose Model>Component I>Electric Currents, Shell>Terminals>ecs.V0_2Terminal voltage.
4 Locate the Expressions section. In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| ecs.I0_1 | mA | Terminal current |
| ecs.V0_2-ecs.V0_3 | mV | Device Output |

5 Click Evaluate.

## Residual Stress in a Thin-Film Resonator-2D

## Introduction

Almost all surface-micromachined thin films experience residual stress as a result of the fabrication process. The most common source of residual stress is thermal stress, which is caused by a change in temperature experienced during the fabrication sequence and also due to the difference in the coefficient of thermal expansion between the film and the substrate. This tutorial shows how to model thermal residual stress due to a temperature difference and how it changes the resonant frequency of a thin-film resonator. The substrate is not included in the model and it is also assumed that at a given state (which indicates a particular step of the process sequence), the temperature is uniform throughout the cantilever.


Figure 1: A thin-film resonator with four straight cantilever beam springs.
The tutorial investigates two design choices; a resonator with straight cantilevers
(Figure 1) and another one with folded cantilevers (Figure 2). For each of the designs, the resonant frequency is computed for the cases when the structure is unstressed and when it
is subjected to a residual thermal stress. The results obtained are compared with analytical solutions.


Figure 2: A thin-film resonator with four folded cantilever beam springs.

## Model Definition

This tutorial uses the dimensions and material properties presented in Table 1 and Table 2. These values were obtained from the example in Chapter 27.2.5 in Ref. 1. It calculates the length of the folded cantilever using the equivalent spring-constant relationship discussed later.

This simulation models thermal residual stress using the Thermal Expansion feature in the Solid Mechanics interface. The coefficient of thermal expansion is computed by assuming a residual stress of 50 MPa in the straight cantilevers, a film deposition temperature of $605{ }^{\circ} \mathrm{C}$ (see Chapter 16.13.2.3 in Ref. l ) and a room temperature of $25^{\circ} \mathrm{C}$.
table I: DImensions of the structure.

| PARAMETER | STRAIGH <br> CANTLLEVERS | FOLDED CANTILEVERS <br> L1 |  | L2 | L3 | PLATE |
| :--- | :--- | :--- | :--- | :--- | :--- | :--- |
| Length | $200 \mu \mathrm{~m}$ | $170 \mu \mathrm{~m}$ | $10 \mu \mathrm{~m}$ | $146 \mu \mathrm{~m}$ | $250 \mu \mathrm{~m}$ |  |
| Width | $2 \mu \mathrm{~m}$ | $2 \mu \mathrm{~m}$ | $2 \mu \mathrm{~m}$ | $2 \mu \mathrm{~m}$ | $120 \mu \mathrm{~m}$ |  |
| Thickness | $2.25 \mu \mathrm{~m}$ | $2.25 \mu \mathrm{~m}$ | $2.25 \mu \mathrm{~m}$ | $2.25 \mu \mathrm{~m}$ | $2.25 \mu \mathrm{~m}$ |  |

TABLE 2: MATERIAL PROPERTIES OF THE STRUCTURE.

| PROPERTY | VALUE |
| :--- | :--- |
| Material | polysilicon |
| Young's modulus | 155 GPa |
| Poisson's ratio | 0.23 |
| Density | $2330 \mathrm{~kg} / \mathrm{m}^{3}$ |
| $\mathrm{~T}_{0}$ | $605^{\circ} \mathrm{C}$ |
| $\mathrm{T}_{\text {I }}$ | $25^{\circ} \mathrm{C}$ |

In order to determine the eigenfrequencies for the case with residual stress, a PrestressedEigenfrequency Study is used. This predefined study type first solves for a static thermal expansion problem to compute the residual stress. The solution of this static problem is then used to create a shift in the linearization point around which the eigenfrequencies are then computed. This approach accurately computes the shift in eigenfrequency by accounting for the stress-stiffening effect.

## 2D ANALYTICAL MODEL

For a lateral resonator with four cantilever-beam springs, the first in-plane bending resonant frequency is given by Equation 1.

$$
\begin{equation*}
f_{0} \approx \frac{1}{2 \pi} \sqrt{\frac{4 E t b^{3}}{m L^{3}}+\frac{24 \sigma_{\mathrm{r}} t b}{5 m L}} \tag{1}
\end{equation*}
$$

Here $m$ is the mass of the resonator plate, $E$ is Young's modulus, $L$ is the length of each cantilever arm, $b$ is its width, $t$ is its thickness, and $\sigma_{\mathrm{r}}$ is the residual stress in each cantilever. In this tutorial, the stress is assumed to be purely because of temperature difference but in reality it could be a sum of external stresses, the thermal stress, and intrinsic components. Assuming the material is isotropic, the stress is constant through the film thickness, and the stress component in the direction normal to the substrate is zero (i.e. plane stress). The stress-strain relationship is then given by Equation 2. Here $v$ is the Poisson's ratio.

$$
\begin{equation*}
\sigma_{\mathrm{r}}=\left(\frac{E}{1-v}\right) \varepsilon \tag{2}
\end{equation*}
$$

The strain comes from $\varepsilon=\alpha \Delta T$ where $\alpha$ is the thermal-expansion coefficient of the cantilever material and $\Delta T$ is the difference between the deposition temperature and the normal operating temperature.

Thermal residual stress in thin-film spring structures is typically relieved by folding the flexures as shown in Figure 2. The flexures relieve axial stress because each is free to expand or contract in the axial direction.

The basic folded structure is a U-shaped spring. For springs in series, the equivalent spring constant is given by Equation 3 .

$$
\begin{equation*}
\frac{1}{k_{\mathrm{eq}}}=\frac{1}{k_{1}}+\frac{1}{k_{2}}+\frac{1}{k_{3}} \tag{3}
\end{equation*}
$$

The first and third springs are cantilever beams. The equivalent spring constant for these can be computed as $k=3 E I / L^{3}$, where $I$ is the moment of inertia. For a beam with rectangular cross-section and for a rotation about the local $y$-axis of the beam (the axis parallel to the in-plane width), the moment of inertia is $I=b t^{3} / 12$, where $b$ is the width and $t$ is the structure's thickness. You can treat the second spring as a column with a spring constant of $k=A E / L$, where $A$ is the cross-sectional area $A=b t$. Assuming the spring thickness $(t)$ and width $(b)$ are the same everywhere, Equation 3 can be used to find the equivalent length of each set of folded springs. The equivalent length can be expressed in terms of the out-of-plane thickness $(t)$ and the length of each of the three sections of a folded cantilever as shown in Equation 4.

$$
\begin{equation*}
L_{\mathrm{eq}}^{3}=L_{1}^{3}+\frac{t^{2} L_{2}}{4}+L_{3}^{3} \tag{4}
\end{equation*}
$$

Using the information provided in Table 1 and Table 2 and by using Equation 1 and Equation 2, one could compute the resonant frequency for the unstressed and stressed thin-film resonator with straight cantilever. Additionally by using Equation 4 along with the other information, one could also find the resonant frequency for the unstressed resonator with folded cantilevers. Note that the residual stress in the folded cantilevers are negligible by design and hence there is no need to compute the resonant frequency for this scenario. A summary of the analytical results are shown in Table 3 where they are compared with the solution obtained from the 2D plane-stress COMSOL model.

## Results and Discussion

Table 3 summarizes the resonant frequencies for the first in-plane bending eigenmode. For the 2D COMSOL models this is the lowest (first) eigenmode. As the table shows, the resonant frequency for the straight cantilevers increases significantly when the model includes residual stress. The model results agree closely with the analytical estimates. As
expected, the stress sensitivity of the resonant frequency is reduced by folding the cantilevers.

TABLE 3: RESONANT FREQUENCIES WITH AND WITHOUT RESIDUAL STRESS.

|  | STRAIGHT CANTILEVERS |  | FOLDED CANTILEVERS |  |
| :--- | :--- | :--- | :--- | :--- | :--- |
|  | ANALYTICAL | 2D MODEL | ANALYTICAL | 2D MODEL |
| Without stress | 14.99 kHz | 14.82 kHz | 14.97 kHz | 14.11 kHz |
| With residual stress | 33.08 kHz | 32.05 kHz | - | 14.22 kHz |

Figure 3 and Figure 4 show the first in-plane bending resonance mode for the unstressed resonator with straight and folded cantilevers respectively.


Figure 3: The first in-plane bending eigenmode of the unstressed resonator with straight cantilevers.


Figure 4: The first in-plane bending eigenmode of the unstressed resonator with folded cantilevers.

Figure 5 and Figure 6 show the first in-plane bending resonance mode for the resonator with straight and folded cantilevers respectively when they have a residual thermal stress.


Figure 5: The first in-plane bending eigenmode of the resonator with straight cantilevers having residual thermal stress.


Figure 6: The first in-plane bending eigenmode of the resonator with folded cantilevers having residual thermal stress.

Figure 7 and Figure 8 show the residual thermal stress (von Mises stress) distribution in the resonator with straight and folded cantilevers respectively when they are cooled from $605{ }^{\circ} \mathrm{C}$ to $25^{\circ} \mathrm{C}$. Figure 7 shows that the residual stress is almost uniform in the straight cantilever and is about 49 MPa . The maximum stress is about 55 MPa at the two ends of the cantilevers. Figure 8 shows that the folded configuration significantly reduces the residual stress build-up. In this case the residual stress is around 2 MPa in most part of the cantilever except near the fixed end where it is close to 39 MPa .


Figure 7: Residual thermal stress in the resonator with straight cantilevers when it is cooled from $605{ }^{\circ} \mathrm{C}$ to $25^{\circ} \mathrm{C}$.


Figure 8: Residual thermal stress in the resonator with folded cantilevers when it is cooled from $605^{\circ} \mathrm{C}$ to $25^{\circ} \mathrm{C}$.

## Reference

1. M. Gad-el-Hak, ed., The MEMS Handbook, CRC Press, London, 2002, ch. 16.12 and 27.2.5.

Application Library path: MEMS_Module/Actuators/
residual_stress_resonator_2d

## Modeling Instructions

From the File menu, choose New.

## N E W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D.

2 In the Select Physics tree, select Structural Mechanics>Solid Mechanics (solid).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Eigenfrequency.
6 Click Done.
Load in the required global parameters. As well as defining some model variables, these values are used later for comparison between the model and the analytical solution.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 Click Load from File.
4 Browse to the model's Application Libraries folder and double-click the file residual_stress_resonator_2d_parameters.txt.

First create a component to model the resonator with straight cantilevers. For convenience, the device geometry will be inserted from an existing file. You can read the instructions for creating the geometry in the .

## GEOMETRY I

I On the Geometry toolbar, click Insert Sequence.
2 Browse to the model's Application Libraries folder and double-click the file residual_stress_resonator_2d_geom_sequence.mph.

3 In the Insert Sequence from File dialog box, click OK.
4 On the Geometry toolbar, click Build All.
Next set up the required solid mechanics physics for the problem by adding a Thermal Expansion sub-feature and specifying the fixed boundaries.

## SOLID MECHANICS (SOLID)

I In the Model Builder window, under Component I (compl) click Solid Mechanics (solid).
2 In the Settings window for Solid Mechanics, locate the 2D Approximation section.
3 From the list, choose Plane stress.
4 Locate the Thickness section. In the $d$ text field, type thickness.

## Thermal Expansion 1

I In the Model Builder window, under Component I (compI)>Solid Mechanics (solid) rightclick Linear Elastic Material I and choose Thermal Expansion.

2 In the Settings window for Thermal Expansion, locate the Model Input section.
3 In the $T$ text field, type To.
4 Locate the Thermal Expansion Properties section. In the $T_{\text {ref }}$ text field, type T1.

## Fixed Constraint I

I In the Model Builder window, right-click Solid Mechanics (solid) and choose Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.

## 3 Click Paste Selection.

4 In the Paste Selection dialog box, type 5,9,15,19 in the Selection text field.
5 Click OK.
Now add a new material to the component in order to define the required physical properties of the device.

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.
3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | E1 | Pa | Basic |
| Poisson's ratio | nu | nu1 | I | Basic |
| Density | rho | rho1 | $\mathrm{kg} / \mathrm{m}^{3}$ | Basic |
| Coefficient of thermal expansion | alpha | daT | $\mathrm{I} / \mathrm{K}$ | Basic |

Configure a suitable mesh, a Mapped mesh is appropriate for this device geometry.

## MESH I

Distribution I
I In the Model Builder window, under Component I (compl) right-click Mesh I and choose Mapped.

2 Right-click Mapped I and choose Distribution.
3 In the Settings window for Distribution, locate the Boundary Selection section.
4 Click Paste Selection.
5 In the Paste Selection dialog box, type 6,8,16,18 in the Selection text field.
6 Click OK.
7 In the Settings window for Distribution, locate the Distribution section.
8 In the Number of elements text field, type 2.
Size
I In the Model Builder window, under Component I (compl)>Mesh I click Size.
2 In the Settings window for Size, locate the Element Size section.
3 From the Predefined list, choose Extra fine.
4 Click Build AlI.
Add a second component to model the resonator with folded cantilevers. As with the first component, the device geometry will be imported for convenience.

## ROOT

On the Home toolbar, click Component and choose Add Component>2D.

## GEOMETRY 2

I In the Model Builder window, under Component 2 (comp2) click Geometry 2.
2 On the Geometry toolbar, click Insert Sequence.
3 Browse to the model's Application Libraries folder and double-click the file residual_stress_resonator_2d_geom_sequence.mph.

4 In the Insert Sequence from File dialog box, select Geometry 2 in the Select geometry sequence to insert list.

5 Click OK.
6 On the Geometry toolbar, click Build AlI.
Now the solid mechanics physics can be configured, as with the first component. In addition, a material will be added to define the required properties of the second device and an appropriate mesh will be created.

## ADD PHYSICS

I On the Home toolbar, click Add Physics to open the Add Physics window.
2 Go to the Add Physics window.
3 In the tree, select Structural Mechanics>Solid Mechanics (solid).
4 Click Add to Component in the window toolbar.
5 On the Home toolbar, click Add Physics to close the Add Physics window.

## SOLID MECHANICS 2 (SOLID2)

I In the Model Builder window, under Component 2 (comp2) click Solid Mechanics 2 (solid2).

2 In the Settings window for Solid Mechanics, locate the 2D Approximation section.
3 From the list, choose Plane stress.
4 Locate the Thickness section. In the $d$ text field, type thickness.

## Thermal Expansion I

I In the Model Builder window, under Component 2 (comp2)>Solid Mechanics 2 (solid2) right-click Linear Elastic Material I and choose Thermal Expansion.

2 In the Settings window for Thermal Expansion, locate the Model Input section.
3 In the $T$ text field, type TO.
4 Locate the Thermal Expansion Properties section. In the $T_{\text {ref }}$ text field, type T1.

## Fixed Constraint I

I In the Model Builder window, right-click Solid Mechanics 2 (solid2) and choose Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type $28,30,42,44$ in the Selection text field.
5 Click OK.

## MATERIALS

## Material 2 (mat2)

I In the Model Builder window, under Component 2 (comp2) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.

3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | E1 | Pa | Basic |
| Poisson's ratio | nu | nu1 | I | Basic |
| Density | rho | rho1 | $\mathrm{kg} / \mathrm{m}^{3}$ | Basic |
| Coefficient of thermal expansion | alpha | daT | $\mathrm{I} / \mathrm{K}$ | Basic |

MESH 2

## Distribution I

I In the Model Builder window, under Component 2 (comp2) right-click Mesh 2 and choose Mapped.
2 Right-click Mapped I and choose Distribution.
3 In the Settings window for Distribution, locate the Boundary Selection section.

## 4 Click Paste Selection.

5 In the Paste Selection dialog box, type $4,8,10,11,28,30,38,42,44,45,60,62$ in the Selection text field.

6 Click OK.
7 In the Settings window for Distribution, locate the Distribution section.
8 In the Number of elements text field, type 2.
Size
I In the Model Builder window, under Component 2 (comp2)>Mesh 2 click Size.
2 In the Settings window for Size, locate the Element Size section.
3 From the Predefined list, choose Extra fine.
4 Click Build AII.
In order to perform the required computations four studies are required. The first two studies, one for each of the components, are for the case of zero-stress. These studies require one Eigenfrequency solver step, which will be used to calculate the eigenfrequency and mode of each resonator.

## STUDY I

I In the Model Builder window, right-click Study I and choose Rename.

2 In the Rename Study dialog box, type Study 1 - Straight Cantilever, No Stress in the New label text field.

## 3 Click OK.

STUDY I - STRAIGHT CANTILEVER, NO STRESS

## Step I: Eigenfrequency

I In the Settings window for Eigenfrequency, locate the Physics and Variables Selection section.

2 In the table, clear the Solve for check box for the Solid Mechanics 2 (solid2) interface.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Eigenfrequency.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

## Step 1: Eigenfrequency

I In the Model Builder window, under Study 2 click Step I: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Physics and Variables Selection section.

3 In the table, clear the Solve for check box for the Solid Mechanics (solid) interface.
4 In the Model Builder window, right-click Study 2 and choose Rename.
5 In the Rename Study dialog box, type Study 2 - Folded Cantilever, No Stress in the New label text field.

6 Click OK.
The second two studies require two study steps: an initial Stationary study step is used to calculate the residual thermal stress due to the difference between the fabrication and operation temperatures; the solution to this step is then used to shift the linerization point around which the eigenfrequenies are computed in a subsequent Eigenfrequency study step. Prestressed Analysis, Eigenfrequency studies are used as this study type contains the required study steps by default.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Prestressed Analysis, Eigenfrequency.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 3

Step I: Stationary
I In the Model Builder window, under Study 3 click Step I: Stationary.
2 In the Settings window for Stationary, locate the Physics and Variables Selection section.
3 In the table, clear the Solve for check box for the Solid Mechanics 2 (solid2) interface.

## Step 2: Eigenfrequency

I In the Model Builder window, under Study 3 click Step 2: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Physics and Variables Selection section.

3 In the table, clear the Solve for check box for the Solid Mechanics 2 (solid2) interface.
4 In the Model Builder window, right-click Study 3 and choose Rename.
5 In the Rename Study dialog box, type Study 3 - Straight Cantilever, Residual Stress in the New label text field.

6 Click OK.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Prestressed Analysis, Eigenfrequency.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 4

Step I: Stationary
I In the Model Builder window, under Study 4 click Step I: Stationary.

2 In the Settings window for Stationary, locate the Physics and Variables Selection section.
3 In the table, clear the Solve for check box for the Solid Mechanics (solid) interface.
Step 2: Eigenfrequency
I In the Model Builder window, under Study 4 click Step 2: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Physics and Variables Selection section.

3 In the table, clear the Solve for check box for the Solid Mechanics (solid) interface.
4 In the Model Builder window, right-click Study 4 and choose Rename.
5 In the Rename Study dialog box, type Study 4 - Folded Cantilever, Residual Stress in the New label text field.

6 Click OK.
The studies can now be solved and the results visualized.

## STUDY I - STRAIGHT CANTILEVER, NO STRESS

On the Home toolbar, click Compute.

## RESULTS

## Mode Shape (solid)

I In the Model Builder window, under Results right-click Mode Shape (solid) and choose Rename.

2 In the Rename 2D Plot Group dialog box, type Straight Cantilever, No Stress in the New label text field.

3 Click OK.
4 On the Straight Cantilever, No Stress toolbar, click Plot.

## STUDY 2 - FOLDED CANTILEVER, NO STRESS

On the Home toolbar, click Compute.

## RESULTS

Mode Shape (solid2)
I In the Model Builder window, under Results right-click Mode Shape (solid2) and choose Rename.

2 In the Rename 2D Plot Group dialog box, type Folded Cantilever, No Stress in the New label text field.

3 Click OK.
4 On the Folded Cantilever, No Stress toolbar, click Plot.

STUDY 3-STRAIGHT CANTILEVER, RESIDUAL STRESS
On the Home toolbar, click Compute.

## RESULTS

## Mode Shape (solid)

I In the Model Builder window, under Results right-click Mode Shape (solid) and choose Rename.

2 In the Rename 2D Plot Group dialog box, type Straight Cantilever, Residual Stress in the New label text field.

3 Click OK.
4 On the Straight Cantilever, Residual Stress toolbar, click Plot.

STUDY 4 - FOLDED CANTILEVER, RESIDUAL STRESS
On the Home toolbar, click Compute.

## RESULTS

Mode Shape (solid2)
I In the Model Builder window, under Results right-click Mode Shape (solid2) and choose Rename.

2 In the Rename 2D Plot Group dialog box, type Folded Cantilever, Residual Stress in the New label text field.

3 Click OK.
4 On the Folded Cantilever, Residual Stress toolbar, click Plot.

## 2D Plot Group 5

I On the Home toolbar, click Add Plot Group and choose 2D Plot Group.
2 In the Model Builder window, right-click 2D Plot Group 5 and choose Rename.
3 In the Rename 2D Plot Group dialog box, type Residual Stress in Straight Cantilever in the New label text field.

4 Click OK.
5 In the Settings window for 2D Plot Group, locate the Data section.

6 From the Data set list, choose Study 3 - Straight Cantilever, Residual Stress/ Solution Store I (7) (sol4).

## Surface I

I Right-click Residual Stress in Straight Cantilever and choose Surface.
2 In the Settings window for Surface, locate the Expression section.
3 In the Expression text field, type solid.mises.
4 On the Residual Stress in Straight Cantilever toolbar, click Plot.

## 2D Plot Group 6

I On the Home toolbar, click Add Plot Group and choose 2D Plot Group.
2 In the Model Builder window, right-click 2D Plot Group 6 and choose Rename.
3 In the Rename 2D Plot Group dialog box, type Residual Stress in Folded Cantilever in the New label text field.

4 Click OK.
5 In the Settings window for 2D Plot Group, locate the Data section.
6 From the Data set list, choose Study 4 - Folded Cantilever, Residual Stress/ Solution Store 2 (I2) (sol6).

## Surface I

I Right-click Residual Stress in Folded Cantilever and choose Surface.
2 In the Settings window for Surface, locate the Expression section.
3 In the Expression text field, type solid2. mises.
4 On the Residual Stress in Folded Cantilever toolbar, click Plot.

## Appendix - Geometry Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D.
2 In the Select Physics tree, select Structural Mechanics>Solid Mechanics (solid).
3 Click Add.
4 Click Done.

## GEOMETRY I

I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Rectangle I (rl)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 250.
4 In the Height text field, type 120.
Rectangle 2 (r2)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 2.
4 In the Height text field, type 200.
5 Locate the Position section. In the $\mathbf{x}$ text field, type 100.
6 In the $\mathbf{y}$ text field, type 120.
Array I (arrl)
I On the Geometry toolbar, click Transforms and choose Array.
2 Select the object $\mathbf{r} \mathbf{2}$ only.
3 In the Settings window for Array, locate the Size section.
4 In the $\mathbf{x}$ size text field, type 2.
5 In the $y$ size text field, type 2.
6 Locate the Displacement section. In the $\mathbf{x}$ text field, type 48.
7 In the $y$ text field, type -320 .
8 Click Build All Objects.

## ROOT

On the Home toolbar, click Component and choose Add Component>2D.

## GEOMETRY 2

I In the Model Builder window, under Component 2 (comp2) click Geometry 2.
2 In the Settings window for Geometry, locate the Units section.

3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Rectangle I (rl)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 250.
4 In the Height text field, type 120.
Rectangle 2 (r2)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 2.
4 In the Height text field, type 172.
5 Locate the Position section. In the $\mathbf{x}$ text field, type 100.
6 In the $\mathbf{y}$ text field, type 120.
Rectangle 3 (r3)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 12.
4 In the Height text field, type 2.
5 Locate the Position section. In the $\mathbf{x}$ text field, type 100.
6 In the $y$ text field, type 290.
Rectangle 4 (r4)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 2.
4 In the Height text field, type 148.
5 Locate the Position section. In the $\mathbf{x}$ text field, type 110.
6 In the $y$ text field, type 144.
Mirror I (mirl)
I On the Geometry toolbar, click Transforms and choose Mirror.
2 Click the Zoom Extents button on the Graphics toolbar.
3 Select the objects $\mathbf{r 3}, \mathbf{r} \mathbf{2}$, and $\mathbf{r} 4$ only.

4 In the Settings window for Mirror, locate the Input section.
5 Select the Keep input objects check box.
6 Locate the Point on Line of Reflection section. In the $\mathbf{x}$ text field, type 125.
Mirror 2 (mir2)
I On the Geometry toolbar, click Transforms and choose Mirror.
2 Select the objects $\operatorname{mirl(1)}, \mathbf{r 3}, \operatorname{mirl(3)}, \mathbf{r} \mathbf{2}, \mathbf{r 4}$, and $\operatorname{mirl(2)}$ only.
3 In the Settings window for Mirror, locate the Input section.
4 Select the Keep input objects check box.
5 Locate the Point on Line of Reflection section. In the $\boldsymbol{y}$ text field, type 60.
6 Locate the Normal Vector to Line of Reflection section. In the $\mathbf{x}$ text field, type 0.
7 In the $y$ text field, type 1.
8 Click Build All Objects.

## Residual Stress in a Thin-Film Resonator-3D

## Introduction

Almost all surface-micromachined thin films experience residual stress as a result of the fabrication process. The most common source of residual stress is thermal stress, which is caused by a change in temperature experienced during the fabrication sequence and also due to the difference in the coefficient of thermal expansion between the film and the substrate. This tutorial shows how to model thermal residual stress due to a temperature difference and how it changes the resonant frequency of a thin-film resonator. The substrate is not included in the model and it is also assumed that at a given state (which indicates a particular step of the process sequence), the temperature is uniform throughout the cantilever.

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Figure 1: A thin-film resonator with four straight cantilever beam springs.
The tutorial investigates two design choices; a resonator with straight cantilevers (Figure 1) and another one with folded cantilevers (Figure 2). For each of the designs, the resonant frequency is computed for the cases when the structure is unstressed and when it is subjected to a residual thermal stress. The results obtained from these 3D models can
be compared with analytical solutions by referring to the Application Libraries tutorial Residual Stress in a Thin-Film Resonator-2D.


Figure 2: A thin-film resonator with four folded cantilever beam springs.

## Model Definition

This tutorial uses the dimensions and material properties presented in Table 1 and Table 2. These values were obtained from the example in Chapter 27.2.5 in Ref. 1. This simulation models thermal residual stress using the Thermal Expansion feature in the Solid Mechanics interface. The coefficient of thermal expansion is computed by assuming a residual stress of 50 MPa in the straight cantilevers, a film deposition temperature of $605^{\circ} \mathrm{C}$ (see Chapter 16.13.2.3 in Ref. 1) and a room temperature of $25{ }^{\circ} \mathrm{C}$.
table I: dimensions of the structure.

| PARAMETER | straight CANTILEVERS | folded CANTILEVERS |  |  | PLATE |
| :---: | :---: | :---: | :---: | :---: | :---: |
|  |  | Lı | L2 | L3 |  |
| Length | $200 \mu \mathrm{~m}$ | $170 \mu \mathrm{~m}$ | $10 \mu \mathrm{~m}$ | $146 \mu \mathrm{~m}$ | $250 \mu \mathrm{~m}$ |
| Width | $2 \mu \mathrm{~m}$ | $2 \mu \mathrm{~m}$ | $2 \mu \mathrm{~m}$ | $2 \mu \mathrm{~m}$ | $120 \mu \mathrm{~m}$ |
| Thickness | $2.25 \mu \mathrm{~m}$ | $2.25 \mu \mathrm{~m}$ | $2.25 \mu \mathrm{~m}$ | $2.25 \mu \mathrm{~m}$ | $2.25 \mu \mathrm{~m}$ |

TABLE 2: MATERIAL PROPERTIES OF THE STRUCTURE.

| PROPERTY | VALUE |
| :--- | :--- |
| Material | polysilicon |
| Young's modulus | I 55 GPa |
| Poisson's ratio | 0.23 |
| Density | $2330 \mathrm{~kg} / \mathrm{m}^{3}$ |
| $\mathrm{~T}_{0}$ | $605^{\circ} \mathrm{C}$ |
| $\mathrm{T}_{\text {I }}$ | $25^{\circ} \mathrm{C}$ |

In order to determine the eigenfrequencies for the case with residual stress, a PrestressedEigenfrequency Study is used. This predefined study type first solves for a static thermal expansion problem to compute the residual stress. The solution of this static problem is then used to create a shift in the linearization point around which the eigenfrequencies are then computed. This approach accurately computes the shift in eigenfrequency by accounting for the stress-stiffening effect.

## Results and Discussion

Table 3 summarizes the resonant frequencies for the first in-plane bending eigenmode. The solutions from the 3D models are compared with those obtained from a 2D planestress model available in the Application Libraries tutorial Residual Stress in a Thin-Film Resonator-2D. As the table shows, the resonant frequency for the straight cantilevers increases significantly when the model includes residual stress. As expected, the stress sensitivity of the resonant frequency is reduced by folding the cantilevers. The results from the 3D models agree closely with those obtained from the 2D models. This indicates that such thin-film resonators can be efficiently modeled using a 2D plane-stress approach.

TABLE 3: RESONANT FREQUENCIES WITH AND WITHOUT RESIDUAL STRESS.

|  | STRAIGHT CANTILEVERS |  | FOLDED CANTILEVERS |  |
| :--- | :--- | :--- | :--- | :--- |
|  | 2D MODEL | 3D MODEL | 2D MODEL | 3D MODEL |
| Without stress | 14.82 kHz | 14.91 kHz | 14.11 kHz | 14.18 kHz |
| With residual stress | 32.05 kHz | 32.25 kHz | 14.22 kHz | 14.29 kHz |

Note that for the 2D models, the first (lowest) eigenmode is the in-plane bending mode. However for the 3D models, the first (lowest) eigenmode is an out-of-plane torsional mode that you see in the default plot when you solve the Eigenfrequency study. The desired in-plane bending mode is the second eigenmode in the list of computed solutions. Hence, the main advantage of the 3D model is in finding any eigenmode where the resonator deforms largely in the out-of-plane direction.

Figure 3 and Figure 4 show the first in-plane bending resonance mode for the unstressed resonator with straight and folded cantilevers respectively.

Eigenfrequency $=1.493 \mathrm{E} 4 \mathrm{~Hz}$ Surface: Total displacement ( $\mu \mathrm{m}$ )


Figure 3: The first in-plane bending eigenmode of the unstressed resonator with straight cantilevers.


Figure 4: The first in-plane bending eigenmode of the unstressed resonator with folded cantilevers.

Figure 5 and Figure 7 show the first in-plane bending resonance mode for the resonator with straight and folded cantilevers respectively when they have a residual thermal stress.

## Eigenfrequency $=3.229 \mathrm{E} 4 \mathrm{~Hz}$ Surface: Total displacement ( $\mu \mathrm{m}$ )



Figure 5: The first in-plane bending eigenmode of the resonator with straight cantilevers having residual thermal stress.

Surface: von Mises stress ( $\mathrm{N} / \mathrm{m}^{2}$ )


Figure 6: Residual thermal stress in the resonator with straight cantilevers when it is cooled from $605^{\circ} \mathrm{C}$ to $25^{\circ} \mathrm{C}$.

Figure 6 and Figure 8 show the residual thermal stress (von Mises stress) distribution in the resonator with straight and folded cantilevers respectively when they are cooled from $605^{\circ} \mathrm{C}$ to $25^{\circ} \mathrm{C}$. Figure 6 shows that the residual stress is almost uniform in the straight cantilever and is about 49 MPa . Figure 8 shows that the folded configuration significantly reduces the residual stress build-up. In this case the residual stress is around 2 MPa in most part of the cantilever except near the fixed end where it is close to 44 MPa .

Eigenfrequency $=1.43 \mathrm{E} 4 \mathrm{~Hz} \quad$ Surface: Total displacement $(\mu \mathrm{m})$


Figure 7: The first in-plane bending eigenmode of the resonator with folded cantilevers having residual thermal stress.

## Surface: von Mises stress ( $\mathrm{N} / \mathrm{m}^{2}$ )



Figure 8: Residual thermal stress in the resonator with folded cantilevers when it is cooled from $605^{\circ} \mathrm{C}$ to $25^{\circ} \mathrm{C}$.

## Reference

1. M. Gad-el-Hak, ed., The MEMS Handbook, CRC Press, London, 2002, ch. 16.12 and 27.2.5.

Application Library path: MEMS_Module/Actuators/
residual_stress_resonator_3d

## Modeling Instructions.

From the File menu, choose New.

## N E W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.

2 In the Select Physics tree, select Structural Mechanics>Solid Mechanics (solid).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Eigenfrequency.
6 Click Done.
Load in the required global parameters. As well as defining some model variables, these values are used later for comparison between the model and the analytical solution.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 Click Load from File.
4 Browse to the model's Application Libraries folder and double-click the file residual_stress_resonator_3d_parameters.txt.

First create a component to model the resonator with straight cantilevers. For convenience, the device geometry will be inserted from an existing file. You can read the instructions for creating the geometry in the .

## GEOMETRY I

I On the Geometry toolbar, click Insert Sequence.
2 Browse to the model's Application Libraries folder and double-click the file residual_stress_resonator_3d_geom_sequence.mph.

3 In the Insert Sequence from File dialog box, click OK.
4 On the Geometry toolbar, click Build All.
Next set up the required solid mechanics physics for the problem by adding a Thermal Expansion sub-feature and specifying the fixed boundaries.

## SOLID MECHANICS (SOLID)

## Thermal Expansion I

I In the Model Builder window, under Component I (compl)>Solid Mechanics (solid) rightclick Linear Elastic Material I and choose Thermal Expansion.
2 In the Settings window for Thermal Expansion, locate the Model Input section.
3 In the $T$ text field, type TO.

4 Locate the Thermal Expansion Properties section. In the $T_{\text {ref }}$ text field, type T1.

## Fixed Constraint I

I In the Model Builder window, right-click Solid Mechanics (solid) and choose Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 7,15,21,29 in the Selection text field.
5 Click OK.
Now add a new material to the component in order to define the required physical properties of the device.

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compI) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.
3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | E 1 | Pa | Basic |
| Poisson's ratio | nu | nu1 | I | Basic |
| Density | rho | $\mathrm{rho1}$ | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |
| Coefficient of thermal expansion | alpha | daT | $\mathrm{I} / \mathrm{K}$ | Basic |

Configure a suitable mesh, a Mapped and swept mesh is appropriate for this device geometry.

## MESH I

## Mapped I

I In the Model Builder window, under Component I (compl) right-click Mesh I and choose More Operations>Mapped.

2 In the Settings window for Mapped, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 4,9,14,23,28 in the Selection text field.

## 5 Click OK.

Distribution I
I Right-click Component I (compI)>Mesh I>Mapped I and choose Distribution.
2 In the Settings window for Distribution, locate the Edge Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 16,21,44,49 in the Selection text field.
5 Click OK.
6 In the Settings window for Distribution, locate the Distribution section.
7 In the Number of elements text field, type 2.
Size
I In the Model Builder window, under Component I (compl)>Mesh I click Size.
2 In the Settings window for Size, locate the Element Size section.
3 From the Predefined list, choose Extra fine.

## Distribution I

I In the Model Builder window, right-click Mesh I and choose Swept.
2 Right-click Swept I and choose Distribution.
3 In the Settings window for Distribution, locate the Distribution section.
4 In the Number of elements text field, type 2.
5 Click Build AlI.
Add a second component to model the resonator with folded cantilevers. As with the first component, the device geometry will be inserted for convenience.

ROOT
On the Home toolbar, click Component and choose Add Component>3D.

## GEOMETRY 2

I In the Model Builder window, under Component 2 (comp2) click Geometry 2.
2 On the Geometry toolbar, click Insert Sequence.
3 Browse to the model's Application Libraries folder and double-click the file residual_stress_resonator_3d_geom_sequence.mph.
4 In the Insert Sequence from File dialog box, select Geometry 2 in the Select geometry sequence to insert list.

5 Click OK.

6 On the Geometry toolbar, click Build All.
Now the solid mechanics physics can be configured, as with the first component. In addition, a material will be added to define the required properties of the second device and an appropriate mesh will be created.

## ADD PHYSICS

I On the Home toolbar, click Add Physics to open the Add Physics window.
2 Go to the Add Physics window.
3 In the tree, select Structural Mechanics>Solid Mechanics (solid).
4 Click Add to Component in the window toolbar.
5 On the Home toolbar, click Add Physics to close the Add Physics window.

SOLID MECHANICS 2 (SOLID2)

## Thermal Expansion I

I In the Model Builder window, under Component 2 (comp2)>Solid Mechanics 2 (solid2) right-click Linear Elastic Material I and choose Thermal Expansion.
2 In the Settings window for Thermal Expansion, locate the Model Input section.
3 In the $T$ text field, type $T 0$.
4 Locate the Thermal Expansion Properties section. In the $T_{\text {ref }}$ text field, type T1.

## Fixed Constraint I

I In the Model Builder window, right-click Solid Mechanics 2 (solid2) and choose Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type $46,48,68,70$ in the Selection text field.
5 Click OK.

## MATERIALS

## Material 2 (mat2)

I In the Model Builder window, under Component 2 (comp2) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.

3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | E 1 | Pa | Basic |
| Poisson's ratio | nu | nu1 | I | Basic |
| Density | rho | $\mathrm{rho1}$ | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |
| Coefficient of thermal expansion | alpha | daT | $\mathrm{I} / \mathrm{K}$ | Basic |

MESH 2

## Mapped I

I In the Model Builder window, under Component 2 (comp2) right-click Mesh 2 and choose More Operations>Mapped.

2 In the Settings window for Mapped, locate the Boundary Selection section.

## 3 Click Paste Selection.

4 In the Paste Selection dialog box, type $4,9,13,18,22,27,36,41,45,50,54,63,67$, $72,76,81,88,93,97,102,106$ in the Selection text field.
5 Click OK.

## Distribution I

I Right-click Component 2 (comp2)>Mesh $\mathbf{2}>$ Mapped I and choose Distribution.
2 In the Settings window for Distribution, locate the Edge Selection section.

## 3 Click Paste Selection.

4 In the Paste Selection dialog box, type $12,21,26,30,73,78,104,113,118,122,161$, 166 in the Selection text field.

5 Click OK.
6 In the Settings window for Distribution, locate the Distribution section.
7 In the Number of elements text field, type 2.

## Distribution I

I In the Model Builder window, right-click Mesh 2 and choose Swept.
2 Right-click Swept I and choose Distribution.
3 In the Settings window for Distribution, locate the Distribution section.
4 In the Number of elements text field, type 2.

## Size

I In the Model Builder window, under Component 2 (comp2)>Mesh 2 click Size.
2 In the Settings window for Size, locate the Element Size section.
3 From the Predefined list, choose Extra fine.

## 4 Click Build AlI.

In order to perform the required computations four studies are required. The first two studies, one for each of the components, are for the case of zero-stress. These studies require one Eigenfrequency solver step, which will be used to calculate the eigenfrequency and mode of each resonator.

## STUDY I

I In the Model Builder window, right-click Study I and choose Rename.
2 In the Rename Study dialog box, type Study 1 - Straight Cantilever, No Stress in the New label text field.

3 Click OK.

## STUDY I - STRAIGHT CANTILEVER, NO STRESS

## Step I: Eigenfrequency

I In the Model Builder window, expand the Study I-Straight Cantilever, No Stress node, then click Step I: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Physics and Variables Selection section.

3 In the table, clear the Solve for check box for the Solid Mechanics 2 (solid2) interface.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Eigenfrequency.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

## Step I: Eigenfrequency

I In the Model Builder window, right-click Study 2 and choose Rename.

2 In the Rename Study dialog box, type Study 2 - Folded Cantilever, No Stress in the New label text field.

## 3 Click OK.

STUDY 2 - $F$ OLDED CANTILEVER, NO STRESS

## Step I: Eigenfrequency

I In the Settings window for Eigenfrequency, locate the Physics and Variables Selection section.

2 In the table, clear the Solve for check box for the Solid Mechanics (solid) interface.
The second two studies require two study steps: an initial Stationary study step is used to calculate the residual thermal stress due to the difference between the fabrication and operation temperatures; the solution to this step is then used to shift the linerization point around which the eigenfrequenies are computed in a subsequent Eigenfrequency study step. Prestressed Analysis, Eigenfrequency studies are used as this study type contains the required study steps by default.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Prestressed Analysis, Eigenfrequency.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 3

Step I: Stationary
I In the Model Builder window, right-click Study 3 and choose Rename.
2 In the Rename Study dialog box, type Study 3 - Straight Cantilever, Residual Stress in the New label text field.

3 Click OK.

STUDY 3 - STRAIGHT CANTILEVER, RESIDUAL STRESS

## Step 1: Stationary

I In the Settings window for Stationary, locate the Physics and Variables Selection section.
2 In the table, clear the Solve for check box for the Solid Mechanics 2 (solid2) interface.

## Step 2: Eigenfrequency

I In the Model Builder window, under Study 3-Straight Cantilever, Residual Stress click Step 2: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Physics and Variables Selection section.

3 In the table, clear the Solve for check box for the Solid Mechanics 2 (solid2) interface.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Prestressed Analysis, Eigenfrequency.
4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 4

Step I: Stationary
I In the Model Builder window, right-click Study 4 and choose Rename.
2 In the Rename Study dialog box, type Study 4 - Folded Cantilever, Residual Stress in the New label text field.

3 Click OK.

STUDY 4 - FOLDED CANTILEVER, RESIDUAL STRESS

## Step I: Stationary

I In the Settings window for Stationary, locate the Physics and Variables Selection section.
2 In the table, clear the Solve for check box for the Solid Mechanics (solid) interface.

## Step 2: Eigenfrequency

I In the Model Builder window, under Study 4 - Folded Cantilever, Residual Stress click Step 2: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Physics and Variables Selection section.

3 In the table, clear the Solve for check box for the Solid Mechanics (solid) interface. The studies can now be solved and the results visualized.

## STUDY I - STRAIGHT CANTILEVER, NO STRESS

On the Home toolbar, click Compute.

## RESULTS

Mode Shape (solid)
I In the Model Builder window, under Results right-click Mode Shape (solid) and choose Rename.

2 In the Rename 3D Plot Group dialog box, type Straight Cantilever, No Stress in the New label text field.

3 Click OK.
4 In the Settings window for 3D Plot Group, locate the Data section.
5 From the Eigenfrequency (Hz) list, choose I.493E4.
6 On the Straight Cantilever, No Stress toolbar, click Plot.

STUDY 2 - FOLDED CANTILEVER, NO STRESS
On the Home toolbar, click Compute.

## RESULTS

Mode Shape (solid2)
I In the Model Builder window, under Results right-click Mode Shape (solid2) and choose Rename.

2 In the Rename 3D Plot Group dialog box, type Folded Cantilever, No Stress in the New label text field.
3 Click OK.
4 In the Settings window for 3D Plot Group, locate the Data section.
5 From the Eigenfrequency (Hz) list, choose I.42E4.
6 On the Folded Cantilever, No Stress toolbar, click Plot.

## STUDY 3 - STRAIGHT CANTILEVER, RESIDUAL STRESS

On the Home toolbar, click Compute.

## RESULTS

Mode Shape (solid)
I In the Model Builder window, under Results right-click Mode Shape (solid) and choose Rename.

2 In the Rename 3D Plot Group dialog box, type Straight Cantilever, Residual Stress in the New label text field.

3 Click OK.
4 In the Settings window for 3D Plot Group, locate the Data section.
5 From the Eigenfrequency (Hz) list, choose 3.229E4.
6 On the Straight Cantilever, Residual Stress toolbar, click Plot.

## STUDY 4 - FOLDED CANTILEVER, RESIDUAL STRESS

On the Home toolbar, click Compute.

## RESULTS

## Mode Shape (solid2)

I In the Model Builder window, under Results right-click Mode Shape (solid2) and choose Rename.

2 In the Rename 3D Plot Group dialog box, type Folded Cantilever, Residual Stress in the New label text field.

3 Click OK.
4 In the Settings window for 3D Plot Group, locate the Data section.
5 From the Eigenfrequency $(\mathrm{Hz})$ list, choose I.43E4.
6 On the Folded Cantilever, Residual Stress toolbar, click Plot.

## 3D Plot Group 5

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Model Builder window, right-click 3D Plot Group 5 and choose Rename.
3 In the Rename 3D Plot Group dialog box, type Residual Stress in Straight Cantilever in the New label text field.

4 Click OK.
5 In the Settings window for 3D Plot Group, locate the Data section.
6 From the Data set list, choose Study 3 - Straight Cantilever, Residual Stress/ Solution Store I (7) (sol4).

## Surface I

I Right-click Residual Stress in Straight Cantilever and choose Surface.
2 In the Settings window for Surface, locate the Expression section.
3 In the Expression text field, type solid.mises.

4 On the Residual Stress in Straight Cantilever toolbar, click Plot.

## 3D Plot Group 6

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Model Builder window, right-click 3D Plot Group 6 and choose Rename.
3 In the Rename 3D Plot Group dialog box, type Residual Stress in Folded Cantilever in the New label text field.

4 Click OK.
5 In the Settings window for 3D Plot Group, locate the Data section.
6 From the Data set list, choose Study 4 - Folded Cantilever, Residual Stress/ Solution Store 2 (12) (sol6).

## Surface I

I Right-click Residual Stress in Folded Cantilever and choose Surface.
2 In the Settings window for Surface, locate the Expression section.
3 In the Expression text field, type solid2. mises.
4 On the Residual Stress in Folded Cantilever toolbar, click Plot.

## Appendix - Geometry Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Solid Mechanics (solid).
3 Click Add.
4 Click Done.

## GEOMETRY I

I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.

## Work Plane I (wpl)

I On the Geometry toolbar, click Work Plane.
2 In the Settings window for Work Plane, click Show Work Plane.

## Rectangle I (rl)

I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 250.
4 In the Height text field, type 120.
Rectangle 2 (r2)
I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 2.
4 In the Height text field, type 200.
5 Locate the Position section. In the xw text field, type 100.
6 In the $\mathbf{y w}$ text field, type 120.
Array I (arrl)
I On the Work Plane toolbar, click Transforms and choose Array.
2 Select the object $\mathbf{r} 2$ only.
3 In the Settings window for Array, locate the Size section.
4 In the xw size text field, type 2.
5 In the yw size text field, type 2.
6 Locate the Displacement section. In the xw text field, type 48.
7 In the $\mathbf{y w}$ text field, type - 320 .
Plane Geometry
I On the Work Plane toolbar, click Build All.
2 In the Model Builder window, click Geometry I.
Extrude I (extl)
I On the Geometry toolbar, click Extrude.
2 In the Settings window for Extrude, locate the Distances section.

3 In the table, enter the following settings:
Distances ( $\mu \mathrm{m}$ )

Distances ( $\mu \mathrm{m}$ )
2.25

4 Click Build All Objects.

ROOT
On the Home toolbar, click Component and choose Add Component>3D.

## GEOMETRY 2

I In the Model Builder window, under Component 2 (comp2) click Geometry 2.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Work Plane I (wpl)
I On the Geometry toolbar, click Work Plane.
2 In the Settings window for Work Plane, click Show Work Plane.
Rectangle I (rl)
I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 250.
4 In the Height text field, type 120.

## Rectangle 2 (r2)

I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 2.
4 In the Height text field, type 172.
5 Locate the Position section. In the xw text field, type 100.
6 In the yw text field, type 120.
Rectangle 3 (r3)
I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 12.
4 In the Height text field, type 2.

5 Locate the Position section. In the xw text field, type 100.
6 In the yw text field, type 290.
Rectangle 4 (r4)
I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 2.
4 In the Height text field, type 148.
5 Locate the Position section. In the xw text field, type 110.
6 In the $\mathbf{y w}$ text field, type 144.

## Mirror I (mirl)

I On the Work Plane toolbar, click Transforms and choose Mirror.
2 Click the Zoom Extents button on the Graphics toolbar.
3 Select the objects $\mathbf{r 3}, \mathbf{r 4}$, and $\mathbf{r 2}$ only.
4 In the Settings window for Mirror, locate the Input section.
5 Select the Keep input objects check box.
6 Locate the Point on Line of Reflection section. In the $\mathbf{x w}$ text field, type 125.
Mirror 2 (mir2)
I On the Work Plane toolbar, click Transforms and choose Mirror.
2 Select the objects $\operatorname{mirl(3)}, \mathbf{r 3}, \operatorname{mirl}(\mathbf{2}), \operatorname{mirl}(\mathbf{I}), \mathbf{r 4}$, and $\mathbf{r 2}$ only.
3 In the Settings window for Mirror, locate the Input section.
4 Select the Keep input objects check box.
5 Locate the Point on Line of Reflection section. In the yw text field, type 60.
6 Locate the Normal Vector to Line of Reflection section. In the xw text field, type 0.
7 In the $\mathbf{y w}$ text field, type 1.
8 In the Model Builder window, click Geometry 2.
Extrude I (extl)
I On the Geometry toolbar, click Extrude.
2 In the Settings window for Extrude, locate the Distances section.
3 In the table, enter the following settings:
2.25

4 Click Build All Objects.

## Pull-in of an RF MEMS Switch

## Introduction

This model analyzes an RF MEMS switch consisting of a thin micromechanical bridge suspended over a dielectric layer. A DC voltage greater than the pull-in voltage is applied across the switch, causing the bridge to collapse onto the dielectric layer with a resulting increase in the capacitance of the device. A penalty based contact force is implemented to model the contact forces as the bridge comes into contact with the dielectric.

## Model Definition

Figure 1 shows the device geometry. The switch consists of a square polysilicon plate suspended $0.9 \mu \mathrm{~m}$ above a $0.1 \mu \mathrm{~m}$ thick thin film of Silicon Nitride (relative dielectric constant 7.5). Beneath the substrate is a silicon counter-electrode that is grounded. The plate is structurally anchored to the substrate by four rectangular flexures at its corners but is electrically isolated from it. Initially a small potential of just 1 mV is applied to the polysilicon. This voltage is sufficient to measure the DC capacitance of the device. After $25 \mu$ s the applied voltage is increased by 5 V with a step function that has a rise time of $10 \mu \mathrm{~s}$. The applied voltage is greater than the pull-in voltage of the structure and the switch pulls down onto the nitride. This process results in an abrupt and significant change in the capacitance of the device. Due to the symmetry of the device, it is possible to model only a single quadrant of the structure. The electromechanics interface explicitly meshes the gap between the polysilicon and the nitride. Since it is not possible to collapse the mesh to zero thickness the mesh is compressed into the nitride layer as the structure deforms. The nitride layer itself is consequently not represented explicitly within the geometry, but instead is represented by means of a spatially varying function for the dielectric constant within the gap. The dielectric constant in the gap is represented by a smoothed step function. The mid point of the step is chosen to be slightly above the height of the dielectric, so that when the polysilicon is in contact with the nitride the dielectric constant in the gap takes the value of the nitride dielectric constant for throughout the gap.


Figure 1: Top: Device geometry showing anchor points and symmetry planes. Bottom: Model geometry. Due to symmetry only one quadrant of the device needs to be modeled.

The contact between the polysilicon and the nitride is handled by an approximate penalty or barrier method, as described in Ref. 1. Stiff, nonlinear springs are used to represent the surface of the nitride. When the polysilicon is away from the nitride surface these springs have low stiffness and consequently have a negligible influence on the deformation. As the gap is reduced and approaches a predefined distance the spring becomes much stiffer and resists further closure. The contact forces $F_{c}$ are given by:

$$
\begin{gathered}
F_{c}=t_{n}-e_{n} \cdot g \quad g<0 \\
F_{c}=t_{n}+\exp \left(-\frac{e_{n}}{t_{n}} \cdot g\right) \quad g \geq 0
\end{gathered}
$$

where $t_{\mathrm{n}}$ is the input estimate of the contact force, $e_{n}$ is the penalty stiffness, $g$ is the gap, that is, the distance between the polysilicon and the nitride. Note that when this method
is employed it is important to correctly tune the elastic stiffness and the contact force. The technique is an approximate one and does not correctly reproduce the details of the dynamics of contact. However the model is primarily concerned with estimating the time the switch takes to make contact and with computing the initial and final capacitance of the switch.

## Results and Discussion

Figure 2 shows the spatial dependence of the total displacement when the device is pulled in. Most of the structure is in contact with the nitride and the bending occurs primarily in the flexures and in the vicinity of their attachment points. The form of the contact pressure, shown in Figure 3, is consistent with this observation and it is interesting to note that the largest forces occur in the vicinity of the flexures.

Time $=5 \mathrm{E}-5 \mathrm{~s}$ Surface: Total displacement ( $\mu \mathrm{m}$ )


Figure 2: Displacement of the polysilicon when pulled in. Most of the polysilicon structure is in contact with the silicon nitride with a displacement of $0.9 \mu \mathrm{~m}$.


Figure 3: Contact forces acting on the polysilicon when the structure is pulled in.
Figure 4 shows the displacement of the switch as a function of time. The switch takes significantly longer to close than the timescale on which the voltage changes, primarily due to its inertia. Figure 5 shows the capacitance of the device as a function of time. The capacitance increases by a factor of approximately 55 . Note that the capacitance changes on a significantly shorter timescale than the displacement.


Figure 4: Displacement of the center of the device as a function of time.


Figure 5: Capacitance of the device as a function of time. The transients in this plot that occur after the point of contact are not physical. The capacitance of the structure changes from 0.1 pF to 1.5 pF as a result of the pull-in.

## Reference

1. Crisfield M. A., Non-linear Finite Element Analysis of Solids and Structures, volume 2: Advanced Topics, John Wiley \& Sons Ltd., England, 1997.

Application Library path: MEMS_Module/Actuators/rf_mems_switch

## Modeling Instructions

From the File menu, choose New.
NEW
In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Electromechanics (emi).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Stationary.
6 Click Done.
GEOMETRY I
I In the Model Builder window, under Component I (compI) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.

3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| V0 | $1[\mathrm{mV}]$ | 0.00 I V | Initial voltage |
| Vstep | $5[\mathrm{~V}]$ | 5 V | Voltage step |
| insheight | $100[\mathrm{~nm}]$ | $\mathrm{IE}-7 \mathrm{~m}$ | Insulator height |
| airheight | $900[\mathrm{~nm}]$ | $9 \mathrm{E}-7 \mathrm{~m}$ | Air height |
| en | $1 \mathrm{e} 15[\mathrm{~Pa} / \mathrm{m}]$ | $\mathrm{IEI5} \mathrm{N/m}^{3}$ | Spring stiffness |
| tn | $5 e 5[\mathrm{~Pa}]$ | 5 E 5 Pa | Contact force |

## DEFINITIONS

## Variables I

I On the Home toolbar, click Variables and choose Local Variables.
2 In the Settings window for Variables, locate the Variables section.
3 In the table, enter the following settings:

| Name | Expression | Unit | Description |
| :--- | :--- | :--- | :--- |
| gap | airheight+w | m |  |
| contactpressure | $($ gap<= <br> 0)* (tn-en*gap)+(gap> | $\mathrm{N} / \mathrm{m}^{2}$ |  |
| Va | Vo+Vstep*step2(t/1[s]) | V |  |

GEOMETRY I
Work Plane I (wpl)
I On the Geometry toolbar, click Work Plane.
2 In the Settings window for Work Plane, click Show Work Plane.

## Rectangle I (rl)

I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 110.
4 In the Height text field, type 5.
5 Locate the Position section. In the $\mathbf{x w}$ text field, type -60.
Rectangle 2 (r2)
I On the Work Plane toolbar, click Primitives and choose Rectangle.

2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 50.
4 In the Height text field, type 60.
5 Locate the Position section. In the $\mathbf{y w}$ text field, type - 10.

## Rectangle 3 (r3)

I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 110.
4 In the Height text field, type 60.
5 Locate the Position section. In the $\mathbf{x w}$ text field, type - 60 .
6 In the $\mathbf{y w}$ text field, type - 10 .
Rectangle 4 (r4)
I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 110.
4 In the Height text field, type 10.
5 Locate the Position section. In the $\mathbf{x w}$ text field, type -60.
6 In the $\mathbf{y w}$ text field, type -2.5.
7 In the Model Builder window, click Geometry I.
Extrude I (extl)
I On the Geometry toolbar, click Extrude.
2 In the Settings window for Extrude, locate the Distances section.
3 In the table, enter the following settings:

| Distances $(\mu \mathrm{m})$ |
| :--- |
| 1 |
| 2 |
| 4 |

4 Right-click Extrude I (extI) and choose Build Selected.

## Form Union (fin)

I On the Geometry toolbar, click Build AlI.
2 Click the Wireframe Rendering button on the Graphics toolbar.

## DEFINITIONS

Step I (stepl)
I On the Home toolbar, click Functions and choose Local>Step.
2 In the Settings window for Step, locate the Parameters section.
3 In the Location text field, type 1.05*insheight.
4 Click to expand the Smoothing section. In the Size of transition zone text field, type $0.05 *$ insheight.

Step 2 (step2)
I On the Home toolbar, click Functions and choose Local>Step.
2 In the Settings window for Step, locate the Parameters section.
3 In the Location text field, type 3e-5.
4 Click to expand the Smoothing section. In the Size of transition zone text field, type 1 e 5.

Define selections.

## Explicit I

I On the Definitions toolbar, click Explicit.
2 In the Model Builder window, right-click Explicit I and choose Rename.
3 In the Rename Explicit dialog box, type Bridge in the New label text field.
4 Click OK.
5 Select Domains $8,23,26$, and 29 only.
Box I
I On the Definitions toolbar, click Box.
2 In the Model Builder window, right-click Box I and choose Rename.
3 In the Rename Box dialog box, type Gap in the New label text field.

## 4 Click OK.

5 In the Settings window for Box, locate the Box Limits section.
6 In the $\mathbf{z}$ maximum text field, type 1.1.
7 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

Adjacent I
I On the Definitions toolbar, click Adjacent.

2 In the Model Builder window, right-click Adjacent I and choose Rename.
3 In the Rename Adjacent dialog box, type Bridge surface in the New label text field.
4 Click OK.
5 In the Settings window for Adjacent, locate the Input Entities section.
6 Under Input selections, click Add.
7 In the Add dialog box, select Bridge in the Input selections list.
8 Click OK.
Box 2
I On the Definitions toolbar, click Box.
2 In the Model Builder window, right-click Box 2 and choose Rename.
3 In the Rename Box dialog box, type Base in the New label text field.
4 Click OK.
5 In the Settings window for Box, locate the Geometric Entity Level section.
6 From the Level list, choose Boundary.
7 Locate the Box Limits section. In the $\mathbf{z}$ maximum text field, type 0.1.
8 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

Box 3
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.
4 Locate the Box Limits section. In the $\mathbf{z}$ minimum text field, type 0.9.
5 In the $\mathbf{z}$ maximum text field, type 1.1.
6 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

## Intersection I

I On the Definitions toolbar, click Intersection.
2 In the Model Builder window, right-click Intersection I and choose Rename.
3 In the Rename Intersection dialog box, type Bridge lower side in the New label text field.

4 Click OK.
5 In the Settings window for Intersection, locate the Geometric Entity Level section.

6 From the Level list, choose Boundary.
7 Locate the Input Entities section. Under Selections to intersect, click Add.
8 In the Add dialog box, In the Selections to intersect list, choose Bridge surface and Box 3.
9 Click OK.

Box 4
I On the Definitions toolbar, click Box.
2 In the Model Builder window, right-click Box 4 and choose Rename.
3 In the Rename Box dialog box, type Symmetry x in the New label text field.
4 Click OK.
5 In the Settings window for Box, locate the Geometric Entity Level section.
6 From the Level list, choose Boundary.
7 Locate the Box Limits section. In the $\mathbf{x}$ minimum text field, type 45.
8 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

Box 5
I On the Definitions toolbar, click Box.
2 In the Model Builder window, right-click Box 5 and choose Rename.
3 In the Rename Box dialog box, type Symmetry y in the New label text field.
4 Click OK.
5 In the Settings window for Box, locate the Geometric Entity Level section.
6 From the Level list, choose Boundary.
7 Locate the Box Limits section. In the y minimum text field, type 45.
8 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

Load the materials.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select Built-In>Air.
4 Click Add to Component in the window toolbar.

ADD MATERIAL
I Go to the Add Material window.
2 In the tree, select MEMS $>$ Semiconductors $>$ Si - Polycrystalline Silicon.
3 Click Add to Component in the window toolbar.
4 On the Home toolbar, click Add Material to close the Add Material window.

## MATERIALS

## Si - Polycrystalline Silicon (mat2)

I In the Model Builder window, under Component I (compl)>Materials click Si Polycrystalline Silicon (mat2).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Bridge.

## Material 3 (mat3)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Gap.
4 Click to expand the Material properties section. Locate the Material Properties section. From the Material type list, choose Nonsolid.

5 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Relative permittivity | epsilonr | $7.5-$ step1 (z)*6.5 | I | Basic |

## ELECTROMECHANICS (EMI)

In the Model Builder window, expand the Electromechanics (emi) node.

## Linear Elastic Material I

I Right-click Component I (compl)>Electromechanics (emi) and choose Linear Elastic Material.

2 In the Settings window for Linear Elastic Material, locate the Domain Selection section.
3 From the Selection list, choose Bridge.

## Fixed Constraint I

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Structural>Fixed Constraint.

2 Select Boundary 24 only.

## Symmetry I

I Right-click Electromechanics (emi) and choose the boundary condition Structural> Symmetry.

2 In the Settings window for Symmetry, locate the Boundary Selection section.
3 From the Selection list, choose Symmetry $\mathbf{x}$.

## Symmetry 2

I Right-click Electromechanics (emi) and choose the boundary condition Structural> Symmetry.

2 In the Settings window for Symmetry, locate the Boundary Selection section.
3 From the Selection list, choose Symmetry y.

## Boundary Load I

I Right-click Electromechanics (emi) and choose the boundary condition Structural> Boundary Load.

2 Select Boundaries 26, 79, 89, and 99 only.
3 In the Settings window for Boundary Load, locate the Force section.
4 Specify the $\mathbf{F}_{\mathrm{A}}$ vector as

| 0 | $x$ |
| :--- | :--- |
| 0 | $y$ |
| contactpressure | $z$ |

Prescribed Mesh Displacement 2
I Right-click Electromechanics (emi) and choose the boundary condition Deformed Mesh> Prescribed Mesh Displacement.

2 In the Settings window for Prescribed Mesh Displacement, locate the Boundary Selection section.

3 From the Selection list, choose Symmetry $\mathbf{x}$.
4 Locate the Prescribed Mesh Displacement section. Clear the Prescribed y displacement check box.

5 Clear the Prescribed z displacement check box.

## Prescribed Mesh Displacement 3

I Right-click Electromechanics (emi) and choose the boundary condition Deformed Mesh> Prescribed Mesh Displacement.
2 In the Settings window for Prescribed Mesh Displacement, locate the Boundary Selection section.

3 From the Selection list, choose Symmetry y.
4 Locate the Prescribed Mesh Displacement section. Clear the Prescribed x displacement check box.

5 Clear the Prescribed z displacement check box.
6 Right-click Electromechanics (emi) and choose the boundary condition Electrical> Terminal.

Define the voltage applied to the bridge lower side.

## Terminal I

I In the Settings window for Terminal, locate the Boundary Selection section.
2 From the Selection list, choose Bridge surface.
3 Locate the Terminal section. From the Terminal type list, choose Voltage.
4 In the $V_{0}$ text field, type $V a$.
5 Right-click Electromechanics (emi) and choose the boundary condition Electrical> Terminal.

Define the voltage applied to the base.

## Terminal 2

I In the Settings window for Terminal, locate the Boundary Selection section.
2 From the Selection list, choose Base.
3 Locate the Terminal section. From the Terminal type list, choose Voltage.
4 In the $V_{0}$ text field, type 0.
5 Right-click Electromechanics (emi) and choose the boundary condition Electrical> Terminal.

Add another Terminal to the bridge lower side. This terminal is used for the first (Stationary) study step. It will be disabled in the transient step which will make Terminal I active.

## Terminal 3

I In the Settings window for Terminal, locate the Boundary Selection section.
2 From the Selection list, choose Bridge surface.

3 Locate the Terminal section. From the Terminal type list, choose Voltage.
4 In the $V_{0}$ text field, type $V 0$.

## MESH I

## Mapped I

I In the Model Builder window, under Component I (comp I) right-click Mesh I and choose More Operations>Mapped.

2 Select Boundaries $10,20,30,40,50,63,73,83,93$, and 103 only.

## Distribution I

I In the Model Builder window, right-click Mesh I and choose Swept.
2 Right-click Swept I and choose Distribution.
3 In the Settings window for Distribution, locate the Domain Selection section.
4 From the Selection list, choose Gap.
5 Locate the Distribution section. In the Number of elements text field, type 8.
6 Click Build AlI.
Define the study steps. The first step (Stationary) is used to define the initial conditions of the transient problem (Step 2).

## STUDY I

## Step 2: Time Dependent

I On the Study toolbar, click Study Steps and choose Time Dependent>Time Dependent.
2 In the Settings window for Time Dependent, locate the Study Settings section.
3 In the Times text field, type range ( $0,5 \mathrm{e}-7,5 \mathrm{e}-5$ ).
4 Locate the Physics and Variables Selection section. Select the Modify physics tree and variables for study step check box.
5 In the Physics and variables selection tree, select Component I (compl)> Electromechanics (emi)>Terminal 3.

6 Click Disable.
Change the default solver to a Fully CoupledDirect solver and use BDF time stepping.
Solution I (soll)
I On the Study toolbar, click Show Default Solver.
2 In the Model Builder window, expand the Solution I (soll) node, then click TimeDependent Solver I.

3 In the Settings window for Time-Dependent Solver, click to expand the Time stepping section.

4 Locate the Time Stepping section. From the Method list, choose BDF.
5 From the Steps taken by solver list, choose Intermediate.
6 Right-click Study I>Solver Configurations>Solution I (solI)>Time-Dependent Solver I and choose Fully Coupled.

7 In the Settings window for Fully Coupled, click to expand the Method and termination section.

8 Locate the Method and Termination section. From the Nonlinear method list, choose Automatic (Newton).
9 In the Model Builder window, under Study I $>$ Solver Configurations>Solution I (soll)> Time-Dependent Solver I right-click Direct and choose Enable.

10 In the Settings window for Direct, locate the General section.
II From the Solver list, choose PARDISO.
12 Click Compute.
Create the mirror solutions.

## RESULTS

## Mirror 3D I

I On the Results toolbar, click More Data Sets and choose Mirror 3D.
2 In the Settings window for Mirror 3D, locate the Plane Data section.
3 In the $\mathbf{x}$-coordinate text field, type 50.

## Mirror 3D 2

I Right-click Mirror 3D I and choose Duplicate.
2 In the Settings window for Mirror 3D, locate the Data section.
3 From the Data set list, choose Mirror 3D I.
4 Locate the Plane Data section. From the Plane list, choose xz-planes.
5 In the $\mathbf{y}$-coordinate text field, type 50.

## Displacement (emi)

I In the Model Builder window, under Results click Displacement (emi).
2 In the Settings window for 3D Plot Group, locate the Data section.
3 From the Data set list, choose Mirror 3D 2.

4 On the Displacement (emi) toolbar, click Plot.
5 Click the Zoom Extents button on the Graphics toolbar.

## Potential (emi)

I In the Model Builder window, under Results click Potential (emi).
2 In the Settings window for 3D Plot Group, locate the Data section.
3 From the Data set list, choose Mirror 3D 2.
4 On the Potential (emi) toolbar, click Plot.
5 Click the Zoom Extents button on the Graphics toolbar.

## Displacement (emi) I

I In the Model Builder window, under Results right-click Displacement (emi) and choose Duplicate.
2 Right-click Displacement (emi) I and choose Rename.
3 In the Rename 3D Plot Group dialog box, type Contact force (emi) in the New label text field.

4 Click OK.
Surface I
I In the Model Builder window, expand the Results>Contact force (emi) node, then click Surface I.

2 In the Settings window for Surface, locate the Expression section.
3 In the Expression text field, type contactpressure.
4 On the Contact force (emi) toolbar, click Plot.
5 Click the Zoom Extents button on the Graphics toolbar.
ID Plot Group 4
I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 4 and choose Rename.
3 In the Rename ID Plot Group dialog box, type Displacement in the New label text field.
4 Click OK.

## Point Graph I

I Right-click Displacement and choose Point Graph.
2 Select Point 70 only.
3 In the Settings window for Point Graph, locate the y-Axis Data section.

4 In the Expression text field, type w.
5 On the Displacement toolbar, click Plot.
6 Click the Zoom Extents button on the Graphics toolbar.

## ID Plot Group 5

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 5 and choose Rename.
3 In the Rename ID Plot Group dialog box, type Capacitance in the New label text field.
4 Click OK.
Global I
I Right-click Capacitance and choose Global.
2 In the Settings window for Global, locate the y-Axis Data section.
3 In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| 4*emi.Q0_1/emi.V0_1 | F | Capacitance |

4 Click to expand the Legends section. Clear the Show legends check box.
5 On the Capacitance toolbar, click Plot.
6 Click the Zoom Extents button on the Graphics toolbar.

## Surface Acoustic Wave Gas Sensor

## Introduction

A surface acoustic wave (SAW) is an acoustic wave propagating along the surface of a solid material. Its amplitude decays rapidly, often exponentially, with the depth of the material. SAWs are featured in many kinds of electronic components, including filters, oscillators, and sensors. SAW devices typically use electrodes on a piezoelectric material to convert an electric signal to a SAW, and back again.

In this model, you investigate the resonance frequencies of a SAW gas sensor. The sensor consists of an interdigitated transducer (IDT) etched onto a piezoelectric $\mathrm{LiNbO}_{3}$ (lithium niobate) substrate and covered with a thin polyisobutylene (PIB) film. The mass of the PIB film increases as PIB selectively adsorbs $\mathrm{CH}_{2} \mathrm{Cl}_{2}$ (dichloromethane, DCM) from air. This causes a shift in resonance which slightly lowers the resonance frequency for the same SAW mode.

## Model Definition

Figure 1 shows a conceptual view of the gas sensor in this model.


Figure 1: SAW gas sensor, showing the IDT electrodes (in black), the thin PIB film (light gray), and the $\mathrm{LiNbO}_{3}$ substrate (dark gray). For the sake of clarity, the dimensions are not to scale and the IDT has fewer electrodes than in common devices. A slice of the geometry is removed to reveal the modeled unit cell (in white).

IDTs used in SAW devices may have hundreds of identical electrodes, and each electrode can be about 100 times longer than it is wide. You can therefore neglect the edge effects and reduce the model geometry to the periodic unit cell shown in Figure 2. The height of this cell does not have to extend all the way to the bottom of the substrate but only a few wavelengths down, so that the SAW has almost died out at the lower boundary.


Figure 2: The geometry of the SAW unit cell used in this model. A 500 nm PIB film covers two $1 \mu \mathrm{~m}$-wide electrodes on top of the $\mathrm{LiNbO}_{3}$ substrate. The substrate domain bas a total beight of $12 \mu \mathrm{~m}$.

Set up the model using the predefined Piezoelectric Devices multiphysics interface. In 2D, a Plane Strain assumption is used for the Solid Mechanics interface. Hence the out-ofplane strain component is zero. This should be a valid assumption, considering that the SAW is generated in the plane of the model and hence any variation in the out-of-plane direction can be considered minimal.

## BOUNDARY CONDITIONS

In order to define the model, you need to apply structural and electrical boundary conditions.

As one can assume that the surface wave dies off within two to three wavelengths from the surface, the lower boundary is fixed. This enforces a zero structural displacement but does not contribute to any significant reflection from the lower boundary back into the bulk of the substrate as long as we are observing surface waves and in particular Rayleigh waves.

The electrodes have a much higher electrical conductivity compared to PIB and $\mathrm{LiNbO}_{3}$. Hence, one can expect each of the electrodes to be isopotential. This is why you do not need to model the domains that constitute the electrodes but can simply use appropriate boundary conditions on all the outer boundaries of each electrode to indicate what type of isopotential state it is in. The boundaries of the left terminal is set to electrical ground, and those of the right terminal are assigned to a Floating Potential with zero surface charge accumulation. This combination of electrical boundary conditions corresponds to an open circuit configuration, which is typically suitable for sensing applications.

Use periodic boundary conditions to dictate that the electric potential and displacements are the same along both vertical boundaries of the geometry. When using periodic boundary conditions, one needs to ensure that the mesh on the vertical boundaries on the left of the unit cell and the vertical boundaries on the right of the unit cell are identical. This is achieved by first creating the mesh on the vertical boundaries on the left and then using the Copy Edge feature to create the exact same mesh on the vertical boundaries on the right.

All other boundaries are left to the default boundary conditions which are Free for the Solid Mechanics interface and Zero Charge for the Electrostatics interface, respectively.

## MATERIAL PROPERTIES

The substrate used in the simulation is YZ -cut $\mathrm{LiNbO}_{3}$ with the following properties (cited in Ref. 2):

- Elasticity matrix:
$\left[\begin{array}{cccccc}2.424 \mathrm{e} 11 & 0.752 \mathrm{e} 11 & 0.752 \mathrm{e} 11 & 0 & 0 & 0 \\ & 2.03 \mathrm{e} 11 & 0.573 \mathrm{e} 11 & 0 & 0.085 \mathrm{e} 11 & 0 \\ & & 2.03 \mathrm{e} 11 & 0 & -0.085 \mathrm{e} 11 & 0 \\ & & & 0.752 \mathrm{e} 11 & 0 & 0.085 \mathrm{e} 11 \\ & & & & 0.595 \mathrm{e} 11 & 0 \\ & & & & & 0.595 \mathrm{e} 11\end{array}\right]$
- Coupling matrix:
$\left[\begin{array}{cccccc}1.33 & 0.23 & 0.23 & 0 & 0 & 0 \\ 0 & 0 & 0 & -2.5 & 0 & 3.7 \\ 0 & -2.5 & 2.5 & 0 & 3.7 & 0\end{array}\right]$
- Relative permittivity:
$\left[\begin{array}{ccc}28.7 & 0 & 0 \\ & 85.2 & 0 \\ & & 85.2\end{array}\right]$

The density of the PIB film is from Ref. 1. The Poisson's ratio is considered to be 0.48 , and the Young's modulus is set to 10 GPa.

The adsorption of DCM gas is represented as a slight increase of the overall density of the PIB film as shown in the following expression.

$$
\rho=\rho_{P I B}+\text { switch } \cdot \rho_{\mathrm{DCM}, \mathrm{PIB}}
$$

In this model, you use a parameter, switch, whose value can be either 0 or 1 . This allows to solve the model for two cases; once without the effect of adsorbed gas and once with the effect of the adsorbed DCM gas in PIB.

When the sensor is exposed to 100 ppm of DCM in air at atmospheric pressure and room temperature, the "partial density" of DCM in the PIB film can be calculated from

$$
\rho_{\mathrm{DCM}, \mathrm{PIB}}=K M c
$$

where $K=10^{1.4821}$ (Ref. 1 ) is the air/PIB partition coefficient for DCM, $M$ is its molar mass, and $c$

$$
c=\left(c_{0} p\right) /(R T)
$$

is its concentration in air. The DCM concentration, $c$ in moles $/ \mathrm{m}^{3}$ is computed using the Gas Law. Here $c_{0}$ is the concentration in parts per million, $p$ is the pressure, $T$ is the temperature, and $R$ is the gas constant. Any effects of the DCM adsorption on the material properties other than the density are neglected.

Most of the material properties and factors affecting them have been parametrized as shown in Table l. This easily allows the model to be adapted for other materials and operating conditions.

TABLE I: LIST OF PARAMETERS

| NAME | EXPRESSIION | DESCRIPTION |
| :---: | :---: | :---: |
| P | I [atm] | Air pressure |
| T | 25[degC] | Air temperature |
| c0 | 100 | DCM concentration in Ppm |
| c_DCM_air | le-6*c0*p/(R_const*T) | DCM concentration in air |
| M_DCM | 84.93[g/mol] | Molar mass of DCM |
| K | $10^{\wedge} 1.4821$ | PIB/air partition constant for DCM |
| rho_DCM_PIB | K*M_DCM* ${ }^{\text {c_D }}$ DCM_air | Mass concentration of DCM in PIB |
| rho_PIB | $0.918\left[\mathrm{~g} / \mathrm{cm}^{\wedge} 3\right]$ | Density of PIB |
| E_PIB | $10[\mathrm{GPa}]$ | Young's modulus of PIB |
| nu_PIB | 0.48 | Poisson's ratio of PIB |
| eps_PIB | 2.2 | Relative permittivity of PIB |
| switch | 0 | Switch for adding DCM density |
| vR | 3488[m/s] | Rayleigh wave velocity |
| width | 4[um] | Width of unit cell |
| f0 | vR/width | Estimated SAW frequency |
| t_PIB | 0.5[um] | PIB thickness |

## ESTIMATING THE SAW FREQUENCY

The use of periodic boundary condition implies that the frequencies of interest correspond to wavelengths that are integer fractions of the width of the geometry. The lowest SAW eigenmode has its wavelength equal to the width of the geometry, that is, $4 \mu \mathrm{~m}$. Using this along with the Rayleigh wave velocity for the given piezoelectric substrate material, one can find an estimate of the resonance frequency of interest. The information can be used in the eigenfrequency solver, which helps it to find out the resonance frequencies close to this estimated number. In this model, you use a YZ-cut $\mathrm{LiNbO}_{3}$ whose Rayleigh wave velocity ( vR ) is around $3488 \mathrm{~m} / \mathrm{s}$. This gives an estimate of the lowest SAW frequency (f0) to be 872 MHz .

## Results and Discussion

The anti-resonance and resonance frequencies evaluate to approximately 850 MHz and 855 MHz , respectively. Figure 3 and Figure 4 show the corresponding SAW modes. Figure 5 and Figure 6 show the electric potential distribution characteristics for these solutions.

Exposing the sensor to a 100 ppm concentration of DCM in air leads to a resonance frequency shift of approximately 200 Hz downwards. This is computed by evaluating the resonance frequency before and after adding the density of adsorbed DCM to that of the PIB domain.

Note that the computational mesh is identical in both these solutions. This implies that the relative error of the frequency shift is similar to that of the resonance frequency itself. Thus, the shift is accurately evaluated despite being a few magnitudes smaller than the absolute error of the resonance frequency.


Figure 3: Deformed shape plot of the anti-resonance SAW mode.


Figure 4: Deformed shape plot of the resonance SAW mode.
switch(1)=0 Eigenfrequency $=8.49 \mathrm{E} 8 \mathrm{~Hz}$ Surface: Electric potential (V)


Figure 5: Electric potential distribution and deformations at anti-resonance, anti-symmetric with respect to the center of each electrode.


Figure 6: Electric potential distribution at resonance, symmetric with respect to the center of each electrode.

## References

\author{

1. K. Ho, E. R. Lindgren, K. S. Rawlinson, L. K. McGrath, and J. L. Wright, "Development of a Surface Acoustic Wave Sensor for In-Situ Monitoring of Volatile Organic Compounds," Sensors vol. 3, pp. 236-247, 2003. <br> 2. S. Ahmadi, F. Hassani, C. Korman, M. Rahaman, and M. Zaghloul, "Characterization of Multi- and Single-layer Structure SAW Sensor," Sensors 2004, Proceedings of IEEE, vol. 3, pp. 1129-1132, 2004.
}

Application Library path: MEMS_Module/Sensors/saw_gas_sensor

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D.
2 In the Select Physics tree, select Structural Mechanics>Piezoelectric Devices.
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces> Eigenfrequency.

6 Click Done.

## GLOBAL DEfinitions

For quicker modeling, load the parameters from a file.

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 Click Load from File.

4 Browse to the model's Application Libraries folder and double-click the file saw_gas_sensor_parameters.txt.

## GEOMETRY I

I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Rectangle I (rl)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type width.
4 In the Height text field, type $3^{*}$ width+t_PIB.
5 Locate the Position section. In the $\mathbf{y}$ text field, type $-3^{*}$ width.
6 Click to expand the Layers section. In the table, enter the following settings:

| Layer name | Thickness $(\mu \mathrm{m})$ |
| :--- | :--- |
| Layer 1 | t_PIB |

7 Select the Layers on top check box.
8 Clear the Layers on bottom check box.
9 Right-click Rectangle I (rI) and choose Build Selected.
Rectangle 2 (r2)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type width/4.
4 In the Height text field, type 0.4*t_PIB.
5 Locate the Position section. In the $\mathbf{x}$ text field, type width/8.
6 Right-click Rectangle 2 (r2) and choose Build Selected.
Copy I (copyl)
I On the Geometry toolbar, click Transforms and choose Copy.
2 Select the object $\mathbf{r 2}$ only.
3 In the Settings window for Copy, locate the Displacement section.
4 In the $\mathbf{x}$ text field, type width/2.

## 5 Click Build All Objects.

Before creating materials, define the domains where each physics apply.

## SOLID MECHANICS (SOLID)

Piezoelectric Material I
I In the Model Builder window, under Component I (compl)>Solid Mechanics (solid) click Piezoelectric Material I.

2 In the Settings window for Piezoelectric Material, locate the Domain Selection section.
3 Click Clear Selection.
4 Select Domain 1 only.

## ELECTROSTATICS (ES)

On the Physics toolbar, click Solid Mechanics (solid) and choose Electrostatics (es).
The electrical equations are not solved in the aluminum electrodes because they are assumed to be perfect conductors compared to LiNbO 3 and PIB, and hence we consider them to be equipotential regions.

I In the Model Builder window, under Component I (compl) click Electrostatics (es).
2 Select Domains 1 and 2 only.
Charge Conservation, Piezoelectric I
I In the Model Builder window, under Component I (compl)>Electrostatics (es) click Charge Conservation, Piezoelectric I.

2 Select Domain 1 only.

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, type LiNb03 in the Label text field.
3 Locate the Geometric Entity Selection section. Click Clear Selection.
4 Select Domain 1 only.

5 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :---: | :---: | :---: | :---: | :---: |
| Elasticity matrix (Ordering: xx, yy, zz, yz, xz, xy) | cE | $\begin{aligned} & \{242.4[\mathrm{GPa}], \\ & 75.2[\mathrm{GPa}], 203[\mathrm{GPa}], \\ & 75.2[\mathrm{GPa}], 57.3[\mathrm{GPa}], \\ & 203[\mathrm{GPa}], 0,0,0, \\ & 75.2[\mathrm{GPa}], 0,8.5[\mathrm{GPa}], \\ & -8.5[\mathrm{GPa}], 0, \\ & 59.5[\mathrm{GPa}], 0,0,0, \\ & 8.5[\mathrm{GPa}], 0,59.5[\mathrm{GPa}]\} \end{aligned}$ | Pa | Stress-charge form |
| Coupling matrix | eES | $\begin{aligned} & \{1.33,0,0,0.23,0 \\ & -2.5,0.23,0,2.5,0 \\ & -2.5,0,0,0,3.7,0,3.7 \\ & 0\} \end{aligned}$ | $\mathrm{C} / \mathrm{m}^{2}$ | Stress-charge form |
| Relative permittivity | epsilonrS | \{28.7, $85.2,85.2\}$ | I | Stress-charge form |
| Density | rho | 4647 | $\mathrm{kg} / \mathrm{m}^{3}$ | Basic |

Alternately, you can click the Edit button below the Output properties table and use the matrix inputs to enter $\mathrm{CE}, \mathrm{e}$, and epsilonrS according to the material data shown under the Model Definition section.

## Material 2 (mat2)

I Right-click Materials and choose Blank Material.
2 In the Settings window for Material, type PIB in the Label text field.
3 Select Domain 2 only.
4 Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | E_PIB | Pa | Basic |
| Poisson's ratio | nu | nu_PIB | I | Basic |
| Density | rho | rho_PIB+switch* <br> rho_DCM_PIB | $\mathrm{kg} / \mathrm{m}^{3}$ | Basic |
| Relative permittivity | epsilonr | eps_PIB | I | Basic |

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.

3 In the tree, select Built-In>Aluminum.
4 Click Add to Component in the window toolbar.

## MATERIALS

## Aluminum (mat3)

I In the Model Builder window, under Component I (compl)>Materials click Aluminum (mat3).
2 Select Domains 3 and 4 only.
3 On the Home toolbar, click Add Material to close the Add Material window.

## SOLID MECHANICS (SOLID)

On the Physics toolbar, click Electrostatics (es) and choose Solid Mechanics (solid).

## Fixed Constraint I

I In the Model Builder window, under Component I (compl) right-click Solid Mechanics (solid) and choose Fixed Constraint.

2 Select Boundary 2 only.

## Periodic Condition I

I In the Model Builder window, right-click Solid Mechanics (solid) and choose Connections> Periodic Condition.

2 Select Boundaries 1, 3, 16, and 17 only.
This defines periodic condition for the Solid Mechanics physics. By default, the periodicity type is set to Continuity for all dependent variables.

## ELECTROSTATICS (ES)

Ground the left electrode by applying boundary condition on its edges.
Ground I
I In the Model Builder window, under Component I (compl) right-click Electrostatics (es) and choose Ground.

2 Select Boundaries 6-9 only.
Apply a Floating Potential on the edges of the right electrode.

## Floating Potential I

I In the Model Builder window, right-click Electrostatics (es) and choose Floating Potential.
2 Select Boundaries 11-14 only.
Define periodic boundary condition for the Electrostatics physics.

## Periodic Condition I

I Right-click Electrostatics (es) and choose Periodic Condition.
2 Select Boundaries 1, 3, 16, and 17 only.

MESH I

## Edge I

I In the Model Builder window, under Component I (comp I) right-click Mesh I and choose More Operations>Edge.

2 Select Boundaries 1 and 3 only.
Distribution I
I Right-click Component I (compl)>Mesh I>Edge I and choose Distribution.
2 Select Boundary 3 only.
3 In the Settings window for Distribution, locate the Distribution section.
4 In the Number of elements text field, type 4.

## Edge I

Define an increasing mesh size along the thickness of the piezoelectric substrate.

## Distribution 2

I Right-click Edge I and choose Distribution.
2 Select Boundary 1 only.
3 In the Settings window for Distribution, locate the Distribution section.
4 From the Distribution properties list, choose Predefined distribution type.
5 In the Number of elements text field, type 25.
6 In the Element ratio text field, type 25.
7 Select the Reverse direction check box.
8 Click Build Selected.
Copy Edge I
I In the Model Builder window, right-click Mesh I and choose More Operations>Copy Edge.
2 Select Boundaries 1 and 3 only.
3 In the Settings window for Copy Edge, locate the Destination Boundaries section.
4 Select the Active toggle button.
5 Select Boundaries 16 and 17 only.

## Free Quad I

## I Right-click Mesh I and choose Free Quad.

2 In the Settings window for Free Quad, locate the Domain Selection section.
3 From the Geometric entity level list, choose Domain.
4 Select Domains 2-4 only.
Size I
I Right-click Component I (compI)>Mesh I>Free Quad I and choose Size.
2 In the Settings window for Size, locate the Element Size section.
3 Click the Custom button.
4 Locate the Element Size Parameters section. Select the Maximum element size check box.
5 In the associated text field, type t_PIB/4.

## Mapped I

I In the Model Builder window, right-click Mesh I and choose Mapped.
2 In the Settings window for Mapped, click Build All.


## STUDY I

Set up a Parametric Sweep to solve the model with and without the adsorbed species on the sensor. The parameter switch is used to solve the model once without adding the density of DCM and once with the added density of adsorbed DCM in PIB.

## Parametric Sweep

I On the Study toolbar, click Parametric Sweep.
2 In the Settings window for Parametric Sweep, locate the Study Settings section.
3 Click Add.
4 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| switch | 01 |  |

Search for eigenfrequencies near the estimated resonance frequency.

## Step I: Eigenfrequency

I In the Model Builder window, under Study I click Step I: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Study Settings section.
3 Select the Search for eigenfrequencies around check box.
4 In the associated text field, type f0.
5 On the Study toolbar, click Compute.

## RESULTS

## Mode Shape (solid)

The default plot shows the anti-resonance SAW mode near 850 MHz . Adjust the deformed shape plot to see the effect of the wave localization near the surface.

I In the Model Builder window, under Results click Mode Shape (solid).
2 In the Settings window for 2D Plot Group, locate the Data section.
3 From the Parameter value (switch) list, choose $\mathbf{0}$.
4 In the Model Builder window, expand the Mode Shape (solid) node.

## Deformation

I In the Model Builder window, expand the Results>Mode Shape (solid)>Surface I node, then click Deformation.

2 In the Settings window for Deformation, locate the Scale section.
3 Select the Scale factor check box.
4 In the associated text field, type 100.
5 On the Mode Shape (solid) toolbar, click Plot.

6 Click the Zoom Extents button on the Graphics toolbar.
Compare the resulting plot to that in Figure 3.

## Mode Shape (solid)

Plot the second mode shape near 855 MHz , which is the resonance SAW mode.
I In the Model Builder window, under Results click Mode Shape (solid).
2 Click Plot.
3 In the Settings window for 2D Plot Group, locate the Data section.
4 From the Eigenfrequency $(\mathrm{Hz})$ list, choose 8.555E8.
5 On the Mode Shape (solid) toolbar, click Plot.
6 Click the Zoom Extents button on the Graphics toolbar.
Compare the resulting plot to that in Figure 4.

## Electric Potential (es)

To visualize the electric potential distribution for the eigenmodes, follow these steps.

## Surface I

I In the Model Builder window, expand the Results>Electric Potential (es) node, then click Surface I.

2 In the Settings window for Surface, locate the Coloring and Style section.
3 From the Color table list, choose WaveLight.
Electric Potential (es)
I Right-click Results>Electric Potential (es)>Surface I and choose Height Expression.
2 In the Settings window for 2D Plot Group, locate the Data section.
3 From the Parameter value (switch) list, choose $\mathbf{0}$.
4 On the Electric Potential (es) toolbar, click Plot.
5 Click the Zoom Extents button on the Graphics toolbar.
6 From the Eigenfrequency $(\mathbf{H z})$ list, choose 8.555E8.
7 On the Electric Potential (es) toolbar, click Plot.
8 Click the Zoom Extents button on the Graphics toolbar.

## Derived Values

To see all computed eigenfrequencies as a table, follow these steps.
Global Evaluation I
I On the Results toolbar, click Global Evaluation.

2 In the Settings window for Global Evaluation, locate the Data section.
3 From the Data set list, choose Study I/Parametric Solutions I (sol2).
4 From the Table columns list, choose Outer solutions.
5 Click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Solver>freq - Frequency.

6 Click New Table.

## TABLE

I Go to the Table window.
2 Click Full Precision in the window toolbar.
The first 6 digits of the eigenfrequency are the same. Subtracting the new value from the previous value shows that the eigenfrequency with gas exposure is lower by 200 Hz .

## Piezoelectric Shear-Actuated Beam

## Introduction

This example performs a static analysis on a piezoelectric actuator based on the movement of a cantilever beam, using the Piezoelectric Devices predefined multiphysics interface. Inspired by work done by V. Piefort (Ref. 1) and A. Benjeddou (Ref. 2), it models a sandwich beam using the shear mode of the piezoelectric material to deflect the tip.

## Model Definition

## GEOMETRY

The model consists of a $100-\mathrm{mm}$ long sandwiched cantilever beam (Figure 1).


Figure 1: The shear bender geometry. Note that a piezoceramic material replaces part of the foam core.

This beam is composed of a 2 -mm thick flexible foam core sandwiched by two 8 -mm thick aluminum layers. Further, the device replaces part of the foam core with a $10-\mathrm{mm}$ long piezoceramic actuator that is positioned between $x=55 \mathrm{~mm}$ and $x=65 \mathrm{~mm}$. The cantilever beam is orientated along the global $x$-axis.

## BOUNDARY CONDITIONS

- Solid Mechanics: the cantilever beam is fixed at its surfaces at $x=0$; all other surfaces are free.
- Electrostatics: The system applies a 20 V potential difference between the top and bottom surfaces of the piezoceramic domain (Figure 2). This gives rise to an electric field perpendicular to the poling direction ( $x$ direction) and thus induces a transverse shear strain.


Figure 2: Applied voltage through the piezoelectric material

## MATERIAL PROPERTIES

The following table lists the material properties for the aluminum layers and the foam core:

| PROPERTY | ALUMINUM | FOAM | PIEZOCERAMIC |
| :--- | :--- | :--- | :--- |
| E | 70 GPa | 35.3 MPa | - |
| $\nu$ | 0.35 | 0.383 | - |
| $\rho$ | $2700 \mathrm{~kg} / \mathrm{m}^{3}$ | $32 \mathrm{~kg} / \mathrm{m}^{3}$ | $7500 \mathrm{~kg} / \mathrm{m}^{3}$ |

Aluminum is available as a predefined material, whereas you must define the foam material manually.

The piezoceramic material in the actuator, PZT-5H, is already defined in the material library. Thus, you do not need to enter the components of the elasticity matrix, $c_{E}$, the piezoelectric coupling matrix, $e$, or the relative permittivity matrix, $\varepsilon_{r S}$.

## Results

The shear deformation of the piezoceramic core layer and the flexible foam layer induce a bending action. Figure 3 shows the resulting tip deflection. The model calculates this deflection as 83 nm , a result that agrees well with those of Ref. I and Ref. 2.

Surface: Displacement field, Z component (nm)


Figure 3: Tip deflection with the piezoceramic positioned at $x=60 \mathrm{~mm}$.

## Notes About the COMSOL Implementation

The matrix components for the piezoelectric material properties refer to a coordinate system, where the poling direction is the $z$ direction. Because the poling direction of the piezoceramic actuator in this model is aligned with the $x$-axis, you need to use a local coordinate system in the material settings to rotate the piezoceramic material.

More specifically, you define a local coordinate system that is rotated 90 degrees about the global $y$-axis. Then, you use this coordinate system in the piezoelectric material settings to rotate the material so that the polarization direction is aligned with the $x$-axis (Figure 4).

## Coordinate system volume: Base vector system



Figure 4: Definition of local coordinate system to define the piezoelectric orientation. The material is poled along the local $x 3$ direction (blue arrow).

## References

1. V. Piefort, Finite Element Modelling of Piezoelectric Active Structures, Ph.D. thesis, Université Libre de Bruxelles, Belgium, Dept. Mechanical Engineering and Robotics, 2001.
2. A. Benjeddou, M.A. Trindade, and R. Ohayon, A Unified Beam Finite Element Model for Extension and Shear Piezoelectric Actuation Mechanisms, CNAM (Paris, France), Structural Mechanics and Coupled Systems Laboratory, 1997.

Application Library path: MEMS_Module/Piezoelectric_Devices/shear_bender

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Piezoelectric Devices.
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces>Stationary.
6 Click Done.

## Geometry I

I In the Model Builder window, under Component I (compI) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose mm.
Block I (blk I)
I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type 100.
4 In the Depth text field, type 30.
5 In the Height text field, type 18.
6 Right-click Block I (blkI) and choose Build Selected.

## Block 2 (blk2)

I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type 100.
4 In the Depth text field, type 30.
5 In the Height text field, type 2.
6 Locate the Position section. In the $\mathbf{z}$ text field, type 8.

7 Click to expand the Layers section. Find the Layer position subsection. Select the Left check box.
8 Clear the Bottom check box.
9 In the table, enter the following settings:

| Layer name | Thickness (mm) |
| :--- | :--- |
| Layer 1 | 55 |
| Layer 2 | 10 |

10 Click Build All Objects.
II Click the Zoom Extents button on the Graphics toolbar.
The model geometry is now complete.
12 Click the Transparency button on the Graphics toolbar.
The geometry in the Graphics window should now look like that in Figure 1.
I3 Click the Transparency button on the Graphics toolbar.

## DEFINITIONS

Define a coordinate system whose third axis is aligned with the global $x$-axis, that is, the polarization direction of the piezoceramic material. Choose the second axis to be parallel to the global $y$-axis.

## Base Vector System 2 (sys2)

I On the Definitions toolbar, click Coordinate Systems and choose Base Vector System.
2 In the Settings window for Base Vector System, locate the Settings section.
3 Find the Base vectors subsection. In the table, enter the following settings:

|  | $\mathbf{x}$ | $\mathbf{y}$ | $\mathbf{z}$ |
| :--- | :--- | :--- | :--- |
| $\mathbf{x I}$ | 0 | 0 | -1 |
| $\times 3$ | 1 | 0 | 0 |

Leave the other components at their default values. You will use this coordinate system in the piezoelectric material settings.

4 Find the Simplifications subsection. Select the Assume orthonormal check box.

## ELECTROSTATICS (ES)

I In the Model Builder window, under Component I (compl) click Electrostatics (es).
2 In the Settings window for Electrostatics, locate the Domain Selection section.

3 Click Clear Selection.
4 Select Domain 4 only.

## SOLID MECHANICS (SOLID)

On the Physics toolbar, click Electrostatics (es) and choose Solid Mechanics (solid).

## Piezoelectric Material I

I In the Model Builder window, under Component I (compl)>Solid Mechanics (solid) click Piezoelectric Material I.

2 In the Settings window for Piezoelectric Material, locate the Domain Selection section.
3 Click Clear Selection.
4 Select Domain 4 only.
5 Locate the Coordinate System Selection section. From the Coordinate system list, choose Base Vector System 2 (sys2).

## MATERIALS

For the aluminum layers, use a library material.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select MEMS $>$ Metals $>$ AI - Aluminum / Aluminium.
4 Click Add to Component in the window toolbar.

## MATERIALS

AI - Aluminum / Aluminium (mat l)
I In the Model Builder window, under Component I (compl)>Materials click AI Aluminum / Aluminium (matl).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 Click Clear Selection.
4 Select Domains 1 and 3 only.
For the foam core, specify the material properties by hand.

## Material 2 (mat2)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, type Foam in the Label text field.
3 Select Domains 2 and 5 only.
Foam (mat2)
Locate the Material Contents section. In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | $35.3[\mathrm{MPa}]$ | Pa | Basic |
| Poisson's ratio | nu | 0.383 | I | Basic |
| Density | rho | 32 | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |

ADD MATERIAL
I Go to the Add Material window.
The piezoceramic PZT-5H is available as a predefined material.
2 In the tree, select Piezoelectric>Lead Zirconate Titanate (PZT-5H).
3 Click Add to Component in the window toolbar.

## MATERIALS

Lead Zirconate Titanate (PZT-5H) (mat3)
I In the Model Builder window, expand the Component I (compl)>Materials>Foam (mat2) node, then click Component I (compl)>Materials>Lead Zirconate Titanate (PZT5H) (mat3).

2 Select Domain 4 only.
3 On the Home toolbar, click Add Material to close the Add Material window.

## SOLID MECHANICS (SOLID)

## Fixed Constraint I

I In the Model Builder window, under Component I (compl) right-click Solid Mechanics (solid) and choose Fixed Constraint.

2 Select Boundaries 1, 4, and 7 only.

## ELECTROSTATICS (ES)

## Electric Potential I

I In the Model Builder window, under Component I (compl) right-click Electrostatics (es) and choose Electric Potential.

2 Select Boundary 16 only.
3 In the Settings window for Electric Potential, locate the Electric Potential section.
4 In the $V_{0}$ text field, type 20.

## Ground I

I In the Model Builder window, right-click Electrostatics (es) and choose Ground.
2 Select Boundary 17 only.

## MESH I

## Distribution I

I In the Model Builder window, under Component I (compl) right-click Mesh I and choose Swept.

2 Right-click Swept I and choose Distribution.
3 In the Settings window for Distribution, locate the Distribution section.
4 In the Number of elements text field, type 2.

## 5 Click Build AlI.

6 Click the Zoom Extents button on the Graphics toolbar.
The mesh consists of 198 hexahedral elements.


## STUDY I

On the Home toolbar, click Compute.

## RESULTS

## Stress (solid)

Replace the default stress plot by displacement to reproduce the plot shown in Figure 3.
I In the Model Builder window, under Results click Stress (solid).
2 In the Settings window for 3D Plot Group, type Displacement (solid) in the Label text field.

## Surface I

I In the Model Builder window, expand the Results>Displacement (solid) node, then click Surface I.

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>Displacement field (material and geometry frames) $>\mathbf{w}$ - Displacement field, $Z$ component.

3 Locate the Expression section. From the Unit list, choose nm.
4 On the Displacement (solid) toolbar, click Plot.

## 5 Click Go to Default View.

## Multislice I

In the Model Builder window, expand the Electric Potential (es) node.

## Surface I

I Right-click Multislice I and choose Delete.
2 In the Model Builder window, under Results right-click Electric Potential (es) and choose Surface.

3 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Electrostatics>Electric>V Electric potential.

4 On the Electric Potential (es) toolbar, click Plot.
Zoom in to find a plot similar to Figure 2.
5 Click the Zoom In button on the Graphics toolbar.
6 Click the Zoom Extents button on the Graphics toolbar.
Show the base vector that defines the polarization of the piezoelectric material, shown on Figure 4.

## 3D Plot Group 3

I On the Home toolbar, click Add Plot Group and choose 3D Plot Group.
2 In the Settings window for 3D Plot Group, type PZT coordinate system in the Label text field.

## Coordinate System Volume I

I On the PZT coordinate system toolbar, click More Plots and choose Coordinate System Volume.

2 In the Settings window for Coordinate System Volume, locate the Coordinate System section.

3 From the Coordinate system list, choose Base Vector System 2 (sys2).
4 Locate the Positioning section. Find the $\mathbf{x}$ grid points subsection. From the Entry method list, choose Coordinates.

5 In the Coordinates text field, type 60.
6 Find the $y$ grid points subsection. In the Points text field, type 1.
7 Find the $\mathbf{z}$ grid points subsection. In the Points text field, type 1.
8 On the PZT coordinate system toolbar, click Plot.

## Squeeze-Film Gas Damping of a Vibrating Disc

## Introduction

This benchmark model computes the damping force acting on a vibrating disc. The disc is in close proximity to a stationary surface and the damping results from the squeezing of a thin film of gas between the two surfaces. The squeezing action forces out the gas from between the two plates resulting in a damping force that acts to prevent mechanical contact between the two surfaces. The opposite effect takes place when the surfaces move away from each other as gas is drawn back into the bearing.

This model examines the effect of the periodic motion of the disc on the flow developed, including the pressure in the gas and the resulting damping forces. Small amplitude motion is analyzed using a linear frequency domain simulation. A nonlinear transient analysis is performed for small to large amplitude motion. The calculated film pressure and load carrying capacity are compared with analytical results.

## Model Definition

The Thin-Film Flow, Edge interface is used to model the gas film on a flat circular plate. The model is 1D axisymmetric since the film pressure only varies radially. When Thin-Film Flow is assigned to a boundary, this boundary represents a reference surface in the physical device. In practice a small gap exists at the boundary and two impermeable structures, the wall and the base, are located either side of it. Figure 1 shows the configuration of the base and the wall in an arbitrary problem, and defines a number of terms used in the interface.

In this example, the model geometry is 1D axisymmetric and consists of a single line, with length set to the radius of the circular disc. The line is located at the origin and aligned with the $r$-axis. The base is coincident with the reference surface. A pressure is generated in the bearing by a periodic velocity of the wall in a direction normal to the wall.


Figure 1: An example illustrating a typical configuration for thin-film flow.
For non-slip boundary conditions at the wall and the base, the modified Reynolds equation takes the following form for a general frequency domain problem:

$$
\begin{gather*}
p_{t o t}\left(\mathbf{v}_{b} \cdot \mathbf{n}_{r e f}-\mathbf{v}_{w} \cdot \mathbf{n}_{r e f}\right)+i \omega h_{0} p_{f}+\nabla_{t} \cdot\left(h_{0} p_{t o t} \mathbf{v}_{a v}\right)  \tag{1}\\
-p_{t o t}\left(\mathbf{v}_{w} \cdot \nabla_{t} h_{w}+\mathbf{v}_{b} \cdot \nabla_{t} h_{b}\right)=0 \\
\mathbf{v}_{a v}=\frac{1}{2}\left(\mathbf{I}-\mathbf{n}_{r} \mathbf{n}_{r}^{T}\right)\left(\mathbf{v}_{w}+\mathbf{v}_{b}\right)-\frac{h_{0}^{2}}{12 \mu} \nabla_{t} p_{f}
\end{gather*}
$$

where $\rho$ is the fluid density, $\mu$ is its viscosity, $h_{0}$ is the mean film height, $p_{f}$ is the pressure developed as a result of the flow (this is the dependent variable in COMSOL) and $p_{t o t}$ is the total pressure ( $p_{\text {tot }}=p_{A}+p_{f}$, where $p_{A}$ is the ambient pressure). Other terms are defined in Figure 1. A reference surface with normal $\mathbf{n}_{\text {ref }}$ sits in a narrow gap between a wall and base. In COMSOL the vector $\mathbf{n}_{\text {ref }}$ points into the base and out of the wall. The wall moves with a displacement from its initial position with displacement $\mathbf{u}_{\text {wall }}$ and velocity $\mathbf{v}_{\text {wall }}$. Similarly the base moves from its initial position with displacement $\mathbf{u}_{\text {base }}$ and velocity $\mathbf{v}_{\text {base }}$. The compression of the film results in an excess pressure, $p_{f}$, above the ambient pressure, $p_{A}$, and a gas velocity in the gap. At a point on the reference surface the average value of the film velocity along a line perpendicular to the surface is given by the in plane vector $\mathbf{v}_{\text {ave }}$. The motion of the gas results in forces on the wall $\left(\mathbf{F}_{\text {wall }}\right)$ and the base ( $\mathbf{F}_{\text {base }}$ ). The height of the wall above the reference surface is $h_{w}$ whilst the base is a distance $h_{b}$ below the reference surface. The total size of the gap is $h=h_{w}+h_{b}$. At a given point in time $h_{w}=h_{w 1}-\mathbf{n}_{\text {ref }} \cdot \mathbf{n}_{\text {wall }}$ and $h_{b}=h_{b 1}-\mathbf{n}_{\text {ref }} \cdot \mathbf{n}_{\text {wall }}$ where $h_{w 1}$ and $h_{b 1}$ are the initial heights of the wall and base, respectively.

Note that the frequency formulation assumes a small amplitude first order harmonic variation of film pressure, film height and wall velocity at the frequency of interest. The boundary conditions for this model are vanishing pressure due to the flow $\left(p_{f}=0\right)$ at $r=$ $r_{0}$, where $r_{0}$ is the disc radius and symmetry/zero pressure gradient $\left(\mathrm{d} p_{f} / \mathrm{d} r=0\right)$ at $r=0$.

For the case of a 1 D axisymmetric problem Equation 1 can be greatly simplified to derive a simple closed form analytical solution. Note that these simplifications are not made in the simulation itself and consequently there are slight deviations from the analytic results in the model-these cannot be seen in the plots shown here and are not significant (strictly speaking the simulation is more accurate than the analytic results since no assumptions are made). The motion of the disc is in the vertical direction only, and the gap size is uniform across the disc, so a number of the terms in Equation 1 are zero. In this example, the term $i \omega h p_{f}$ is quite small compared to other terms and can be neglected for the purpose of deriving an analytical solution. The ambient pressure is 1 atmosphere and correspondingly $p_{f}<p_{A}$. so $p_{t o t} \approx p_{A}$. Making these assumptions the modified Reynold's equation reduces to:

$$
\begin{equation*}
\frac{1}{r} \frac{d}{d r}\left(\frac{r h_{0}^{3}}{12 \mu} \frac{d p_{f}}{d r}\right)=\mathrm{v}_{w} \tag{2}
\end{equation*}
$$

Where $v_{w}$ is the velocity of the wall in the z-direction. With the boundary conditions $p_{f}=$ 0 at $r=r_{0}$, and $\mathrm{d} p_{f} / \mathrm{d} r=0$ at $r=0$, Equation 2 can be solved for $p_{f}$ and is given by (see Ref. I for complete derivation):

$$
\begin{equation*}
p_{f, a n}=-\frac{3 \mu \mathrm{v}_{w}}{h_{0}^{3}}\left(r_{0}^{2}-r^{2}\right) \tag{3}
\end{equation*}
$$

The total analytical vertical load on the disc is then given by (see Ref. 1 for complete derivation):

$$
F_{a n}=\int_{0}^{r_{0}} 2 \pi r p_{f} d r=-\frac{3 \pi \mu r_{0}^{4} \mathrm{v}_{w}}{2 h_{0}^{3}}
$$

A frequency domain analysis is appropriate for small amplitude periodic motion of the bearing wall. For large amplitude periodic motion (where the amplitude of the motion becomes comparable to the gap size), a transient analysis is necessary, to capture the nonlinearities in the model. Again approximations are required to derive an analytic result for the transient simulation (but are not necessary for the model).

For a transient model the modified Reynolds equation takes the form:

$$
\begin{gather*}
\frac{\partial}{\partial t}\left(p_{t o t} h\right)+\nabla_{t} \cdot\left(h p_{t o t} \mathbf{v}_{a v}\right)-p_{t o t}\left(\mathbf{v}_{w} \cdot \nabla_{t} h_{w}+\mathbf{v}_{b} \cdot \nabla_{t} h_{b}\right)=0  \tag{4}\\
\mathbf{v}_{a v}=\frac{1}{2}\left(\mathbf{I}-\mathbf{n}_{r} \mathbf{n}_{r} T^{2}\right)\left(\mathbf{v}_{w}+\mathbf{v}_{b}\right)-\frac{h^{2}}{12 \mu} \nabla_{t} p_{f}
\end{gather*}
$$

For periodic motion of the wall, the total film height $h$ is $h(t)=h_{0}+\Delta h \sin (2 \pi f t)$, where $\Delta h$ is the amplitude and $f$ is the frequency of wall periodic motion. The wall velocity $v_{\mathrm{w}}$ is then given by $v_{\mathrm{w}}(t)=(2 \pi f \Delta h) \cos (2 \pi f t)$. Once again making the assumption that $p_{\text {tot }} \approx p_{A}$ and noting that a number of these terms are zero for vertical motion of a parallel disc:

$$
\frac{1}{r} \frac{d}{d r}\left(\frac{r h(t)^{3}}{12 \mu} \frac{d p_{f}}{d r}\right)=\mathrm{v}_{w}(t)
$$

Following the derivation of total analytical vertical load for the frequency domain analysis, the total vertical load on the disc for the transient model is given by

$$
F_{a n}(t)=\int_{0}^{r_{0}} 2 \pi r p_{f}(t) d r=-\frac{3 \pi \mu r_{0}^{4} \mathrm{v}_{w}(t)}{2 h(t)^{3}}
$$

The model compares the analytical values of film pressure and total vertical load against the values computed by using the Thin-Film Flow, Edge interface. The results are found to be in agreement with the analytical solutions.

## Results and Discussion

The values of radial film pressure in the gas film for the frequency domain analysis are plotted in Figure 2. As expected, film pressure magnitude is maximum at the center of the circular disc and drops off to zero where the gas film exits the bearing geometry. Figure 2 also compares the numerical radial film pressure values with analytical values calculated using Equation 3. The calculated results agree well with the analytical results. Figure 3 shows an arrow plot of the fluid load per unit area on the circular disc. These values correspond to the film pressure since the vertical load is significantly larger than the radial load. Figure 4 shows the variation of film height (gap) with respect to time for different values of the amplitude of harmonic film height. The corresponding variation of film pressure and total vertical load on the circular disc is shown in Figure 5 and Figure 6, respectively. For larger amplitude of harmonic film height the response in terms of both film pressure and total load are nonlinear with respect to the applied harmonic motion of the circular plate. Such nonlinearity is appropriately calculated by performing a transient analysis. Figure 6 also compares analytical and calculated time dependent values of the
total load on the circular disc. The plot indicates that the calculated values agree well with the analytical values.


Figure 2: Film pressure vs radial distance from the center of the circular disc. The results computed by COMSOL are shown as the continuous curve and the analytical result is shown with green symbols.


Figure 3: Radial distribution of the film load on the wall


Figure 4: Film height variation vs time for different values of amplitude of harmonic film height.


Figure 5: Film pressure vs time for different values of amplitude of harmonic film height. For higher values of film height amplitude the film pressure varies nonlinearly with respect to the film beight.


Figure 6: Total vertical load on the circular dise vs time. for different values of amplitude of harmonic film beight. The results computed by COMSOL are shown by solid continuous curve and the analytical result is shown by dashed continuous curves. Similar to the film pressure, for higher values of film beight amplitude the total load varies nonlinearly with respect to the film beight.

## Reference

1. B.J. Hamrock, S.R. Schmid, and B.O. Jacobson, Fundamentals of Fluid Film Lubrication, Marcel Dekker, 2004.

This model is based on the discussion entitled Parallel-Surface Bearing of infinite width in section 12.2 of the above reference.

Application Library path: MEMS_Module/Sensors/squeeze_film_disc

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D Axisymmetric.
2 In the Select Physics tree, select Fluid Flow>Thin-Film Flow $>$ Thin-Film Flow, Edge (tffs).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Frequency Domain.
6 Click Done.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| r0 | $1[\mathrm{~mm}]$ | 0.00 I m | Disc radius |
| h0 | $10[\mathrm{um}]$ | $\mathrm{IE}-5 \mathrm{~m}$ | Gap height |
| dh | dhND*h0 | IE-7 m | Change in gap height |
| dhND | 0.01 | 0.0 I | Fractional gap height change. |
| mu0 | $1 \mathrm{e}-5[\mathrm{Pa*}$ s | $\mathrm{IE}-5 \mathrm{~Pa} \cdot \mathrm{~s}$ | Gas viscosity |
| f0 | $1000[\mathrm{~Hz}]$ | I 000 Hz | Vibration frequency |

## GEOMETRY I

## Bézier Polygon I (bl)

I On the Geometry toolbar, click Primitives and choose Bézier Polygon.
2 In the Settings window for Bézier Polygon, locate the Polygon Segments section.
3 Find the Added segments subsection. Click Add Linear.
4 Find the Control points subsection. In row $\mathbf{2}$, set $\mathbf{r}$ to ro.
5 Click Build All Objects.
6 Click the Zoom Extents button on the Graphics toolbar.

## DEFINITIONS

## Integration I (intop I)

I On the Definitions toolbar, click Component Couplings and choose Integration.
2 In the Settings window for Integration, locate the Source Selection section.
3 From the Geometric entity level list, choose Boundary.
4 Click in the Graphics window and then press Ctrl+A to select all boundaries.
5 Locate the Advanced section. Select the Compute integral in revolved geometry check box.

## Variables I

I On the Definitions toolbar, click Local Variables.
2 In the Settings window for Variables, locate the Variables section.
3 In the table, enter the following settings:

| Name | Expression | Unit | Description |
| :---: | :---: | :---: | :---: |
| Ftot | intop1(tffs.fwallz) | N | Total force on disc |
| Ftotan | -3*pi*mu0*vf*ro^4/(2*ho^3) | N | Analytic expression |
| vf | 2*pi*f0*dh | $\mathrm{m} / \mathrm{s}$ | Disc velocity |
| Ftotantime | $\begin{aligned} & -6^{*} \mathrm{pi}^{\wedge} 2^{*} \mathrm{mu} 0^{*} \mathrm{f} 0^{*} \mathrm{ro}^{\wedge} 4^{*} \mathrm{dh*} \\ & \cos \left(2^{*} \mathrm{pi}^{*} \mathrm{fo} 0^{*} \mathrm{t}\right) /\left(2^{*}(\mathrm{~h} 0+\mathrm{dh} *\right. \\ & \left.\left.\sin \left(2^{*} \mathrm{pi}^{*} \mathrm{f} 0^{*} \mathrm{t}\right)\right)^{\wedge} 3\right) \\ & \hline \end{aligned}$ | N | Analytic expression |

Analytic I (anl)
I On the Definitions toolbar, click Analytic.
2 In the Settings window for Analytic, type Pan in the Function name text field.
3 Locate the Definition section. In the Expression text field, type -6*pi*mu0*f0*dh* ( $\mathrm{r} 0^{\wedge} 2-\mathrm{rf}^{\wedge} 2$ ) /h0^3.

4 In the Arguments text field, type rf.
5 Locate the Units section. In the Arguments text field, type m.
6 In the Function text field, type Pa.

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.

3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property group |
| :--- | :--- | :--- | :--- | :--- |
| Dynamic viscosity | mu | mu 0 | Pa•s | Basic |

The density is not required because the modified Reynolds equation is solved.

## THIN-FILM FLOW, EDGE (TFFS)

I In the Model Builder window, under Component I (compI) click Thin-Film Flow, Edge (tffs).
2 In the Settings window for Thin-Film Flow, Edge, locate the Equation Type section.
3 From the Equation type list, choose Modified Reynolds equation.

## Fluid-Film Properties I

Reverse the direction of the geometry normal. Note that this is necessary to ensure that the wall load acts in the vertical direction. See for more details on the orientation of the wall and base with respect to the geometric and reference surface normals. To view the orientation of the reference normal, show the default solver settings and then compute only to the dependent variables stage in the study sequence. Then plot the reference surface normal.

I In the Model Builder window, under Component I (compl)>Thin-Film Flow, Edge (tffs) click Fluid-Film Properties I.

2 In the Settings window for Fluid-Film Properties, click to expand the Reference surface properties section.

3 Locate the Reference Surface Properties section. From the Reference normal orientation list, choose Opposite direction to geometry normal.
4 Locate the Wall Properties section. In the $h_{w 1}$ text field, type ho.
5 From the $\mathbf{u}_{w}$ list, choose None.
6 From the $\mathbf{v}_{w}$ list, choose User defined. Specify the vector as

| 0 | $r$ |
| :--- | :--- |
| $v f$ | $z$ |

## Fluid-Film Properties 2

I Right-click Component I (comp I)>Thin-Film Flow, Edge (tffs)>Fluid-Film Properties I and choose Duplicate.
2 Click in the Graphics window and then press Ctrl+A to select all boundaries.

3 In the Settings window for Fluid-Film Properties, locate the Wall Properties section.
4 From the $\mathbf{u}_{w}$ list, choose User defined. Specify the associated vector as

| 0 | $r$ |
| :--- | :--- |
| $d h * \sin (2 * p i * f 0 * t)$ | $z$ |

5 From the $\mathbf{v}_{w}$ list, choose Calculate from wall displacement.

## MESH I

I In the Model Builder window, under Component I (compl) click Mesh I.
2 In the Settings window for Mesh, locate the Mesh Settings section.
3 From the Element size list, choose Extra fine.
4 Click Build AII.
5 Click the Zoom Extents button on the Graphics toolbar.

## STUDY I

Step I: Frequency Domain
I In the Settings window for Frequency Domain, locate the Study Settings section.
2 In the Frequencies text field, type 1000.
3 Locate the Physics and Variables Selection section. Select the
Modify physics tree and variables for study step check box.
4 In the Physics and variables selection tree, select Component I (comp I)>Thin-Film Flow, Edge (tffs)>Fluid-Film Properties 2.
5 Click Disable.
6 In the Physics and variables selection tree, select Component I (compI).
7 On the Home toolbar, click Compute.

## RESULTS

ID Plot Group 2
I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Plot Settings section.
3 Select the $\mathbf{x}$-axis label check box.
4 In the associated text field, type Radial distance (m).
5 Select the $\mathbf{y}$-axis label check box.

6 In the associated text field, type Pressure ( Pa ).
7 Click to expand the Legend section. From the Position list, choose Upper left.

## Line Graph I

I Right-click ID Plot Group 2 and choose Line Graph.
2 Click in the Graphics window and then press Ctrl+A to select all boundaries.
3 In the Settings window for Line Graph, click to expand the Legends section.
4 Select the Show legends check box.
5 From the Legends list, choose Manual.
6 In the table, enter the following settings:

## Legends

COMSOL

Line Graph 2
I In the Model Builder window, under Results right-click ID Plot Group 2 and choose Line Graph.

2 Click in the Graphics window and then press Ctrl+A to select all boundaries.
3 In the Settings window for Line Graph, locate the $\mathbf{y}$-Axis Data section.
4 In the Expression text field, type Pan (r).
5 Click to expand the Coloring and style section. Locate the Coloring and Style section. Find the Line style subsection. From the Line list, choose None.

6 Find the Line markers subsection. From the Marker list, choose Cycle.
7 Locate the Legends section. Select the Show legends check box.
8 From the Legends list, choose Manual.
9 In the table, enter the following settings:

| Legends |
| :--- |
| Analytic Solution |

10 On the ID Plot Group 2 toolbar, click Plot.
II Click the Zoom Extents button on the Graphics toolbar.
ID Plot Group 2
I Right-click ID Plot Group 2 and choose Rename.
2 In the Rename ID Plot Group dialog box, type Radial Pressure in the New label text field.

## 3 Click OK.

## Arrow Line

I On the Home toolbar, click Add Plot Group and choose 2D Plot Group.
2 In the Model Builder window, right-click 2D Plot Group 3 and choose Arrow Line.
3 In the Settings window for Arrow Line, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Thin-Film Flow, Edge> Fluid loads>tffs.fwallr,tffs.fwallz - Fluid load on wall.

4 Locate the Coloring and Style section. In the Number of arrows text field, type 30.
5 Select the Scale factor check box.
6 Use the slider to adjust the arrow length.
7 On the 2D Plot Group 3 toolbar, click Plot.
8 Click the Zoom Extents button on the Graphics toolbar.

## Line I

I In the Model Builder window, under Results right-click 2D Plot Group 3 and choose Line.
2 In the Settings window for Line, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I $>$ Thin-Film Flow, Edge> Fluid loads>Fluid load on wall>tffs.fwallz - Fluid load on wall, z component.

3 Locate the Coloring and Style section. Select the Reverse color table check box.
4 On the 2D Plot Group 3 toolbar, click Plot.
5 Click the Zoom Extents button on the Graphics toolbar.

## 2D Plot Group 3

I Right-click 2D Plot Group 3 and choose Rename.
2 In the Rename 2D Plot Group dialog box, type Wall Load in the New label text field.
3 Click OK.

## Global Evaluation I

I On the Results toolbar, click Global Evaluation.
2 In the Settings window for Global Evaluation, locate the Expressions section.
3 In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| abs (Ftot) | N |  |

4 Click Evaluate.

## Global Evaluation 2

I On the Results toolbar, click Global Evaluation.
2 In the Settings window for Global Evaluation, click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Component I>Definitions> Variables>Ftotan - Analytic expression.

3 Click Table I-Global Evaluation I (abs(Ftot)).

## ROOT

The agreement between the total force computed by COMSOL and the analytic expression is excellent.

Next add a study to solve the problem in the time domain.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Time Dependent.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

STUDY 2

## Step I: Time Dependent

I In the Model Builder window, under Study 2 click Step I: Time Dependent.
2 In the Settings window for Time Dependent, locate the Study Settings section.
3 Click Range.
4 In the Range dialog box, type $1 /(40 * f 0)$ in the Step text field.
5 In the Stop text field, type 5/f0.
6 Click Replace.
7 In the Settings window for Time Dependent, click to expand the Study extensions section.
8 Locate the Study Extensions section. Select the Auxiliary sweep check box.
9 Click Add.

10 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| dhND | 0.010 .10 .20 .3 |  |

II On the Home toolbar, click Compute.

## RESULTS

## ID Plot Group 5

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.
3 From the Data set list, choose Study 2/Solution 2 (sol2).

## Point Graph I

I Right-click ID Plot Group 5 and choose Point Graph.
2 Select Point 1 only.
3 In the Settings window for Point Graph, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I>Thin-Film Flow, Edge $>$ Wall and base properties>tffs.hw - Height of wall above reference plane.

4 On the ID Plot Group 5 toolbar, click Plot.
5 Click to expand the Legends section. Select the Show legends check box.
ID Plot Group 5
I In the Model Builder window, under Results click ID Plot Group 5.
2 In the Settings window for ID Plot Group, click to expand the Axis section.
3 Select the Manual axis limits check box.
4 In the $y$ minimum text field, type 0.
5 Locate the Legend section. From the Position list, choose Lower right.
6 On the ID Plot Group 5 toolbar, click Plot.
7 Right-click Results>ID Plot Group 5 and choose Rename.
8 In the Rename ID Plot Group dialog box, type Wall height vs time in the New label text field.
9 Click OK.
10 On the Wall height vs time toolbar, click Plot.

II Click the Zoom Extents button on the Graphics toolbar.
The wall height varies sinusoidally, as expected. Except in the case when dhND is 0.01 , the height varies by a significant fraction of the gap. This means that the equation system is non-linear.

## ID Plot Group 6

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.
3 From the Data set list, choose Study 2/Solution 2 (sol2).

## Point Graph I

I Right-click ID Plot Group 6 and choose Point Graph.
2 Select Point l only.
3 On the ID Plot Group 6 toolbar, click Plot.
ID Plot Group 6
I In the Model Builder window, under Results right-click ID Plot Group 6 and choose Rename.

2 In the Rename ID Plot Group dialog box, type Pressure vs time in the New label text field.

3 Click OK.
4 On the Pressure vs time toolbar, click Plot.
5 Click the Zoom Extents button on the Graphics toolbar.
Once the wall height varies by a significant fraction of the gap non-linear effects become important. The pressure does not vary sinusoidally any more and it is no longer possible to model the equation straightforwardly in the frequency domain.

When the height variations are small direct comparison with the frequency domain solution is possible. Do this by comparing the maximum value of the pressure in the time domain with the amplitude of the pressure computed in the frequency domain.

## Point Evaluation I

I On the Results toolbar, click Point Evaluation.
2 Select Point 1 only.
3 In the Settings window for Point Evaluation, locate the Expressions section.

4 In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| abs (pfilm) | Pa |  |

## 5 Click Evaluate.

## Point Evaluation 2

I On the Results toolbar, click Point Evaluation.
2 In the Settings window for Point Evaluation, locate the Data section.
3 From the Data set list, choose Study 2/Solution 2 (sol2).
4 From the Parameter selection (dhND) list, choose From list.
5 In the Parameter values (dhND) list, select $\mathbf{0 . 0 1}$.
6 Select Point 1 only.
7 Locate the Data Series Operation section. From the Operation list, choose Minimum.
8 Click Evaluate.

## TABLE

I Go to the Table window.
In this case the time and frequency domain analyses are in good agreement.

## RESULTS

ID Plot Group 7
I On the Results toolbar, click ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.
3 From the Data set list, choose Study 2/Solution 2 (sol2).

## Global I

I Right-click ID Plot Group 7 and choose Global.
2 In the Settings window for Global, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I $>$ Definitions $>$ Variables $>$ Ftot - Total force on disc.

## Global 2

I In the Model Builder window, under Results right-click ID Plot Group 7 and choose Global.

2 In the Settings window for Global, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I > Definitions>Variables> Ftotantime - Analytic expression.
3 Click to expand the Coloring and style section. Locate the Coloring and Style section. Find the Line style subsection. From the Line list, choose Dashed.

## ID Plot Group 7

I In the Model Builder window, under Results click ID Plot Group 7.
2 In the Settings window for ID Plot Group, locate the Axis section.
3 Select the Manual axis limits check box.
4 In the $\mathbf{x}$ minimum text field, type 0.003 .
5 In the $\mathbf{x}$ maximum text field, type 0.005 .
6 Locate the Legend section. From the Position list, choose Lower left.
7 Right-click Results>ID Plot Group 7 and choose Rename.
8 In the Rename ID Plot Group dialog box, type Total force on disc vs time in the New label text field.

9 Click OK.
10 On the Total force on disc vs time toolbar, click Plot.
II Click the Zoom Extents button on the Graphics toolbar.
The agreement between the COMSOL result and the analytic expression is good. The force acting on the disc remains periodic but has higher harmonic components at large displacements relative to the gap size.

## Surface Micromachined Accelerometer

## Introduction

This example shows how to model a surface micromachined accelerometer in COMSOL, using the electromechanics interface. The example is based on the case study in Ref. 1. The model also demonstrates the new geometry feature of Linked Subsequences, first introduced in COMSOL 5.0. A collection of geometric building blocks can be stored in a source model file as Subsequences. Thereafter other model files can re-use the same building blocks by linking to the Subsequences in the source model file. Each Subsequence can take arguments to generate a building block with specific dimensions and/or number of features. In this model a surface micromachined accelerometer is created from three building blocks, two of which are used multiple times by calling the corresponding Subsequence with different arguments.

## Model Definition

The surface micromachined accelerometer is composed of a released proof mass supported by anchored springs at its two ends, together with sensing and self test electrodes extending to the sides. When the device is subject to an acceleration, the restoring force from the springs gives a displacement of the proof mass in proportion to the acceleration. The displacement causes a change in the capacitance between the fixed and moving electrodes. This change in capacitance can be measured with a number of standard circuits.

For acceleration along the axis of the accelerometer, symmetry allows modeling only half of the geometry for faster computation. The three geometric building blocks are the proof mass with attached electrodes (Figure 1), the folded spring (Figure 2), and the fixed electrode array (Figure 3). These building blocks are implemented as Subsequences that take arguments to specify dimensions, orientation, position, and number of features. For example, the proof mass shown in Figure 1 has 7 sense electrodes at the center and 3 self test electrodes at each end. The actual model on the other hand is built with 21 sense electrodes, by calling the same Subsequence with the corresponding argument 21. As another example, Figure 4 shows an electrode array built from the same Subsequence as in Figure 3, with a different set of arguments, resulting in different number of electrodes, dimensions, and orientation of the anchor pads.


Figure 1: Building block for the proof mass with attached electrodes. Grid scales are in micrometers.


Figure 2: Building block for the folded spring. Grid scales are in micrometers.


Figure 3: Building block for the fixed electrode array. Grid scales are in micrometers.


Figure 4: Example of an electrode array built from the same Subsequence as in Figure 3, with a different set of arguments. Grid scales are in micrometers.

The geometry sequence begins by calling the proof mass Subsequence, followed by calling the folded spring Subsequence twice to attach a spring at each end of the proof mass. Subsequently 6 calls to the fixed electrode array Subsequence are made to construct the sense and self test fixed electrodes.

Each Subsequence call contributes to a domain and a boundary selection. This allows easy assignment of domain physics and boundary conditions in the physics interface.

The model uses polysilicon for the building material and includes a rectangular air domain surrounding the polysilicon. The Electromechanics interface models the electric field within the deforming gaps between the electrodes, and applies the appropriate electrostatic forces to the solids, which creates a corresponding structural deformation. The narrowing electrostatics domain results in nonlinear geometrical effects which are included in the Electromechanics interface by default.

The entire polysilicon solid is subject to an acceleration using the Body Load domain physics feature. The (mechanically) fixed electrodes are set at constant potentials, and the proof mass (and its attached electrodes) is at a floating potential whose value will be determined by the position-dependent capacitance (and the applied voltages on the fixed sense electrodes).

## Results and Discussion

The first study illustrates the normal operation of the accelerometer by sweeping the applied acceleration from -50 to +50 g and computing the resulting displacement of the proof mass. Figure 5 shows the displacement of the polysilicon domains when the applied acceleration is 50 g . The proof mass (and the attached moving electrodes) moves by about
0.07 micrometer. The anchored spring bases and the fixed electrodes have very little movement. The folded springs have varying displacement along its length as expected.
acceleration(5)=50 Surface: Total displacement ( $\mu \mathrm{m}$ )


Figure 5: Displacement of the polysilicon domains when the applied acceleration is 50 g . The proof mass moves by about 0.07 micrometer. The anchored spring bases and the fixed electrodes bave very little movement. The springs have varying displacement along its length as expected.


Figure 6: Displacement vs acceleration.
Figure 6 shows the linear relationship between the displacement and the applied acceleration. The displacement is measured via the capacitive coupling between the moving and the fixed sense electrodes. In the real device, during normal operation, the proof mass with its attached moving electrodes is floating at a potential close to one half of the supply voltage, and a high frequency square wave swinging between zero and the full supply voltage is applied with opposite phase to the fixed sense electrodes on each side of the moving electrodes. The fixed self test electrodes are biased at one half of the supply voltage. When the proof mass moves as a result of the acceleration, an alternating voltage in proportion to the displacement is induced due to the capacitive coupling between the fixed and moving electrodes. This arrangement nulls the average electrostatic force between the fixed and moving sense electrodes, and facilitates easier signal processing in the attached circuitry. In this example the stationary part of the square wave is modeled using a stationary study, so that the problem solves relatively quickly. The bias is shifted to zero for convenience, and the amplitude of the square wave is divided by an artificial factor of 1000 to reduce the electrostatic force between the fixed and moving sense electrodes (in practice the time average of the force will be zero due to the high frequency excitation). For a 5 V supply in the physical device, this corresponds to applying a $+/-2.5 \mathrm{mV}$ on the right-side and left-side fixed sense electrodes in the model. In post processing the artificial factor of 1000 is multiplied back to the sensed voltage of the proof mass. Figure 7 shows
the linear relationship between the sense voltage and the acceleration. This signal is fed into an amplifier that in the real device was built on the same substrate as the mechanical structure.


Figure 7: Sensed voltage vs. applied acceleration.
The accelerometer in the model was designed with self test electrodes that could be employed to calibrate the device in the factory. The second study illustrates the self testing by applying a bias of 2 V on the fixed self test electrodes, which are at the side of the moving electrodes attached to the proof mass. The electric field between the fixed and the moving electrodes exerts an electrostatic force that causes the proof mass to move. Figure 8 shows the displacement of the polysilicon domains when 0 V is applied to the fixed self test electrodes on the left-hand side of the moving electrodes attached to the proof mass, and 2 V to those on the right-hand side. The proof mass moves by about $0.02 \mu \mathrm{~m}$, which is large enough in magnitude for the self test purpose (compared to the $0.07 \mu \mathrm{~m}$ of full range displacement shown in Figure 5 and Figure 6).


Figure 8: Displacement of the polysilicon domains when $0 V$ is applied to the fixed self test electrodes on the left-hand side of the moving electrodes attached to the proof mass, and 2 V to those on the right-band side. The proof mass moved by about $0.02 \mu \mathrm{~m}$, which is large enough in magnitude for the self test purpose (compared to the $0.07 \mu \mathrm{~m}$ of full range displacement shown in Figure 5 and Figure 6).

Figure 9 compares the displacement obtained from applying the self test voltage to each side of the fixed electrodes. The displacement values have the same magnitude with opposite signs, as expected from symmetry.


Figure 9: Displacement vs. applied self test voltage.

## References

1. S.D. Senturia, Microsystem Design 5th ed., Kluwer Academic Publishers, pp. 513-525, 2003.

Application Library path: MEMS_Module/Sensors/
surface_micromachined_accelerometer

## Modeling Instructions

Load the geometry file.

## ROOT

I From the File menu, choose Open.

2 Browse to the model's Application Libraries folder and double-click the file surface_micromachined_accelerometer_geom_sequence.mph.

The model geometry has been set up using parts in a linked file. It is easier to visualize with wireframe rendering.

## COMPONENT I (COMPI)

I Click the Wireframe Rendering button on the Graphics toolbar.
2 Click the Zoom Extents button on the Graphics toolbar.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select Built-In>Air.
4 Click Add to Component I.

## ADD MATERIAL

I Go to the Add Material window.
2 In the tree, select MEMS $>$ Semiconductors $>$ Si - Polycrystalline Silicon.
3 Click Add to Component I.

## MATERIALS

Si - Polycrystalline Silicon (mat2)
I In the Model Builder window, under Component I (compl)>Materials click Si Polycrystalline Silicon (mat2).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 From the Selection list, choose Polysilicon.
4 On the Home toolbar, click Add Material to close the Add Material window.

## ELECTROMECHANICS (EMI)

## Linear Elastic Material I

I In the Model Builder window, under Component I (compl) right-click Electromechanics (emi) and choose Linear Elastic Material.
2 In the Settings window for Linear Elastic Material, locate the Domain Selection section.
3 From the Selection list, choose Polysilicon.
4 In the Model Builder window, collapse the Electromechanics (emi) node.

5 In the Model Builder window, expand the Electromechanics (emi) node.
Body Load I
I Right-click Electromechanics (emi) and choose the domain setting Structural>Body Load.
2 In the Settings window for Body Load, locate the Force section.
3 Specify the $\mathbf{F}_{\mathrm{V}}$ vector as

| acceleration*emi.rho*g_const | $x$ |
| :--- | :--- |
| 0 | $y$ |
| 0 | $z$ |

4 Locate the Domain Selection section. From the Selection list, choose Polysilicon.

## Symmetry I

I Right-click Electromechanics (emi) and choose the boundary condition Structural> Symmetry.

2 In the Settings window for Symmetry, locate the Boundary Selection section.
3 From the Selection list, choose Symmetry plane.

## Fixed Constraint I

I Right-click Electromechanics (emi) and choose the boundary condition Structural> Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.
3 From the Selection list, choose Anchor plane.

## Ground I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Ground.

2 Select Boundary 45 only.

## Terminal I

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Terminal.

2 In the Settings window for Terminal, locate the Terminal section.
3 From the Terminal type list, choose Voltage.
4 In the $V_{0}$ text field, type $-2.5[\mathrm{mV}]$.
5 Click the Zoom Extents button on the Graphics toolbar.

6 Locate the Boundary Selection section. From the Selection list, choose Sense left boundaries.

7 Right-click Component I (compl)>Electromechanics (emi)>Terminal I and choose Rename.

8 In the Rename Terminal dialog box, type Sense Terminal L in the New label text field.
9 Click OK.

## Terminal 2

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Electrical>Terminal.
2 In the Settings window for Terminal, locate the Boundary Selection section.
3 From the Selection list, choose Sense right boundaries.
4 Locate the Terminal section. From the Terminal type list, choose Voltage.
5 In the $V_{0}$ text field, type $2.5[\mathrm{mV}$ ].
6 Right-click Component I (compl)>Electromechanics (emi)>Terminal 2 and choose Rename.

7 In the Rename Terminal dialog box, type Sense Terminal R in the New label text field.
8 Click OK.

## Floating Potential I

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Electrical>Floating Potential.
2 In the Settings window for Floating Potential, locate the Boundary Selection section.
3 From the Selection list, choose Proof mass boundaries.

## Terminal 3

I Right-click Electromechanics (emi) and choose the boundary condition Electrical> Terminal.

2 In the Settings window for Terminal, locate the Terminal section.
3 From the Terminal type list, choose Voltage.
4 In the $V_{0}$ text field, type VtestL.
5 Right-click Component I (compI)>Electromechanics (emi)>Terminal $\mathbf{3}$ and choose Rename.

6 In the Rename Terminal dialog box, type Self Test Terminal L in the New label text field.

7 Click OK.

8 In the Settings window for Terminal, locate the Boundary Selection section.
9 From the Selection list, choose Self test left boundaries.

## Terminal 4

I In the Model Builder window, right-click Electromechanics (emi) and choose the boundary condition Electrical>Terminal.

2 In the Settings window for Terminal, locate the Boundary Selection section.
3 From the Selection list, choose Self test right boundaries.
4 Locate the Terminal section. From the Terminal type list, choose Voltage.
5 In the $V_{0}$ text field, type VtestR.
6 Right-click Component I (compl)>Electromechanics (emi)>Terminal 4 and choose Rename.

7 In the Rename Terminal dialog box, type Self Test Terminal R in the New label text field.

8 Click OK.

## MESH I

## Free Triangular I

I In the Model Builder window, under Component I (compl) right-click Mesh I and choose More Operations>Free Triangular.

2 In the Settings window for Free Triangular, locate the Boundary Selection section.
3 From the Selection list, choose Meshing plane.
4 Click Build Selected.
Distribution I
I In the Model Builder window, right-click Mesh I and choose Swept.
2 Right-click Swept I and choose Distribution.
3 In the Settings window for Distribution, locate the Domain Selection section.
4 Click Clear Selection.
5 Select Domain 3 only.
6 Click Build AII.

## STUDY I

I In the Model Builder window, right-click Study I and choose Rename.

2 In the Rename Study dialog box, type Study 1: Normal Operation in the New label text field.

3 Click OK.

STUDY I: NORMAL OPERATION

## Step I: Stationary

I In the Model Builder window, expand the Study I: Normal Operation node, then click Step I: Stationary.

2 In the Settings window for Stationary, click to expand the Study extensions section.
3 Locate the Study Extensions section. Select the Auxiliary sweep check box.
4 Click Add.
5 Click Range.
6 In the Range dialog box, type -50 in the Start text field.
7 In the Step text field, type 25.
8 In the Stop text field, type 50.
9 Click Add.

## Solution I (soll)

I On the Study toolbar, click Show Default Solver.
2 In the Model Builder window, expand the Solution I (soll) node.
3 In the Model Builder window, expand the Study I: Normal Operation> Solver Configurations>Solution I (solI)>Stationary Solver I>Segregated I node.

4 In the Model Builder window, expand the Study I: Normal Operation> Solver Configurations>Solution I (solI)>Stationary Solver I>Iterative I node, then click Study I: Normal Operation>Solver Configurations>Solution I (soll)>Stationary Solver I> Segregated I>Segregated Step I.

5 In the Settings window for Segregated Step, locate the General section.
6 From the Linear solver list, choose Iterative I.
7 In the Model Builder window, under Study I: Normal Operation>Solver Configurations> Solution I (solI)>Stationary Solver I>Iterative I click Multigrid I.

8 In the Settings window for Multigrid, locate the General section.
9 From the Solver list, choose Geometric multigrid.
10 On the Study toolbar, click Compute.

## RESULTS

## Point Graph I

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 3 and choose Point Graph.
3 In the Settings window for Point Graph, locate the Selection section.
4 Select the Active toggle button.
5 Select Point 65 only.
6 Click Replace Expression in the upper-right corner of the $\mathbf{y}$-axis data section. From the menu, choose Component I>Electromechanics (Solid Mechanics)>Displacement> Displacement field (material and geometry frames) $>\mathbf{u}$ - Displacement field, $\mathbf{X}$ component.

## ID Plot Group 3

I In the Model Builder window, under Results right-click ID Plot Group 3 and choose Rename.

2 In the Rename ID Plot Group dialog box, type Displacement vs. Acceleration in the New label text field.

3 Click OK.
4 In the Settings window for ID Plot Group, locate the Plot Settings section.
5 Select the $\mathbf{x}$-axis label check box.
6 In the associated text field, type Acceleration ( g ).
7 On the Displacement vs. Acceleration toolbar, click Plot.

## Global I

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Model Builder window, right-click ID Plot Group 4 and choose Global.
3 In the Settings window for Global, locate the $\mathbf{y}$-Axis Data section.
4 In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| emi.V0_fp1*1000 | mV | Raw sense voltage |

5 Click to expand the Legends section. Clear the Show legends check box.
6 On the ID Plot Group 4 toolbar, click Plot.

## ID Plot Group 4

I In the Model Builder window, under Results right-click ID Plot Group 4 and choose Rename.

2 In the Rename ID Plot Group dialog box, type Sense V vs. Acceleration in the New label text field.

3 Click OK.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies>Stationary.
4 Click Add Study.

## STUDY 2

Step I: Stationary
I On the Home toolbar, click Add Study to close the Add Study window.
2 In the Model Builder window, under Study 2 click Step I: Stationary.
3 In the Settings window for Stationary, locate the Study Extensions section.
4 Select the Auxiliary sweep check box.
5 Click Add.
6 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| VtestL | 20 |  |

7 Click Add.
8 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| VtestR | 02 |  |

9 From the Run continuation for list, choose No parameter.
10 In the Model Builder window, right-click Study 2 and choose Rename.
II In the Rename Study dialog box, type Study 2: Self Test in the New label text field. I2 Click OK.

## STUDY 2: SELF TEST

## Solution 2 (sol2)

I On the Study toolbar, click Show Default Solver.
2 In the Model Builder window, expand the Solution 2 (sol2) node.
3 In the Model Builder window, expand the Study 2: Self Test>Solver Configurations> Solution 2 (sol2)>Stationary Solver I>Segregated I node.

4 In the Model Builder window, expand the Study 2: Self Test>Solver Configurations> Solution 2 (sol2)>Stationary Solver I>Iterative I node, then click Study 2: Self Test> Solver Configurations>Solution 2 (sol2)>Stationary Solver I>Segregated I> Segregated Step I.

5 In the Settings window for Segregated Step, locate the General section.
6 From the Linear solver list, choose Iterative I.
7 In the Model Builder window, under Study 2: Self Test>Solver Configurations> Solution 2 (sol2)>Stationary Solver I>Iterative I click Multigrid I.

8 In the Settings window for Multigrid, locate the General section.
9 From the Solver list, choose Geometric multigrid.
10 On the Study toolbar, click Compute.

## RESULTS

## Displacement (emi) I

Click the Zoom Extents button on the Graphics toolbar.

## Slice I

I In the Model Builder window, expand the Potential (emi) I node, then click Slice I.
2 In the Settings window for Slice, locate the Plane Data section.
3 In the Planes text field, type 8.
4 On the Potential (emi) I toolbar, click Plot.
ID Plot Group 7
I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, locate the Data section.
3 From the Data set list, choose Study 2: Self Test/Solution 2 (sol2).

## Point Graph I

I Right-click ID Plot Group 7 and choose Point Graph.

2 Select Point 65 only.
3 In the Settings window for Point Graph, click Replace Expression in the upper-right corner of the $\mathbf{y}$-axis data section. From the menu, choose Component I>
Electromechanics (Solid Mechanics)>Displacement>
Displacement field (material and geometry frames) $>\mathbf{u}$ - Displacement field, $\mathbf{X}$ component.
4 Locate the x-Axis Data section. From the Parameter list, choose Expression.
5 In the Expression text field, type VtestR.
6 On the ID Plot Group 7 toolbar, click Plot.
ID Plot Group 7
I In the Model Builder window, under Results right-click ID Plot Group 7 and choose Rename.

2 In the Rename ID Plot Group dialog box, type Displacement vs. Self Test V in the New label text field.

3 Click OK.

## Appendix - Geometry Instructions

From the File menu, choose New.

## N E W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Electromechanics (emi).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Stationary.
6 Click Done.

## GLOBAL DEFINITIONS

## Geometry Parts

I In the Model Builder window, right-click Global Definitions and choose Geometry Parts.
2 On the Geometry toolbar, click Parts and choose Load Part.

3 Browse to the model's Application Libraries folder and double-click the file surface_micromachined_accelerometer_geom_subsequence.mph.

4 In the Load Part dialog box, In the Select parts list, choose Proof mass with fingers, Spring and anchor, and Electrode array.

## 5 Click OK.

## ELECTROMECHANICS (EMI)

In the Model Builder window, collapse the Component I (compl)>Electromechanics (emi) node.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 Click Load from File.
4 Browse to the model's Application Libraries folder and double-click the file surface_micromachined_accelerometer_parameters.txt.

## GEOMETRY I

## Proof mass with fingers I (pil)

I On the Geometry toolbar, click Parts and choose Proof mass with fingers.
2 In the Settings window for Part Instance, type Part Link: Proof mass in the Label text field.

3 Locate the Input Parameters section. In the table, enter the following settings:

| Name | Expression | Value | Description |
| :---: | :---: | :---: | :---: |
| I_PM | 1_PM | 4.48E-4 m | Proof mass length |
| w_PM | w_PM | IE-4 m | Proof mass full width |
| t_PM | tSi | 2E-6 m | Proof mass thickness |
| I_f | l_f | $1.14 \mathrm{E}-4 \mathrm{~m}$ | Length of finger |
| w_f | w_f | 4E-6 m | Width of finger |
| n_st | n_st | 3 | Number of self test fingers |
| n _f | n_f | 21 | Number of sense fingers |
| $g \_f$ | g_f | IE-6 m | Gap between sense fingers |
| g_st | g_st | 3E-6 m | Gap between self test fingers |


| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| x_st | x_st | IE-5 m | Starting position of self test fingers |
| x_f | x_f $^{2}$ | $7.2 \mathrm{E}-5 \mathrm{~m}$ | Starting position of sense fingers |
| w_eh | w_eh | $4 \mathrm{E}-6 \mathrm{~m}$ | Etch hole size |
| P_eh | p_eh | I.8E-5 m | Etch hole period |

## 4 Click Build All Objects.

5 Click the Zoom Extents button on the Graphics toolbar.

## Spring and anchor I (pi2)

I On the Geometry toolbar, click Parts and choose Spring and anchor.
2 In the Settings window for Part Instance, type Part Link: Spring 1 in the Label text field.

3 Locate the Input Parameters section. In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| l_sp | l_sp | $2.8 \mathrm{E}-4 \mathrm{~m}$ | Spring length |
| w_sp | w_sp | $2 \mathrm{E}-6 \mathrm{~m}$ | Spring width |
| g_sp | g_sp | IE-6 m | Spring gap |
| w_sp_conn | w_sp_conn | $4 \mathrm{E}-6 \mathrm{~m}$ | Spring connection width |
| w_f | w_f | $4 \mathrm{E}-6 \mathrm{~m}$ | Guard finger width |
| l_anch_base | l_anch_base $^{\text {m }}$ | I.7E-5 m | Anchor base length |
| w_anch_base | w_anch_base | I.7E-5 m | Anchor base width |
| r_anch | r_anch | $3 \mathrm{E}-6 \mathrm{~m}$ | Anchor radius |
| x_anch | x_anch | I.2E-5 m | Anchor position |
| t_sp | tSi | $2 \mathrm{E}-6 \mathrm{~m}$ | Spring thickness |
| t_anch | t0x | I.6E-6 m | Anchor thickness |
| x_sp | l_PM | $4.48 \mathrm{E}-4 \mathrm{~m}$ | Position |

4 Click Build All Objects.

## Part Link: Spring I.I (pi3)

I Right-click Part Link: Spring I and choose Duplicate.
2 In the Settings window for Part Instance, type Part Link: Spring 2 in the Label text field.

3 Locate the Input Parameters section. In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| mirror | 0 | 0 | 0: no mirror. I: mirror |
| I_sp | l_sp+10[um] | $2.9 \mathrm{E}-4 \mathrm{~m}$ | Spring length |
| w_anch_base | w_anch_base $+10[\mathrm{um}]$ | $2.7 \mathrm{E}-5 \mathrm{~m}$ | Anchor base width |
| x_sp | $0[$ um $]$ | 0 m | Position |

4 Click Build All Objects.

## Electrode array I (pi4)

I On the Geometry toolbar, click Parts and choose Electrode array.
2 In the Settings window for Part Instance, locate the Input Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :---: | :---: | :---: | :---: |
| LH | 0 | 0 | 0: RH, I: LH |
| I_e | l_e_l | $1.4 \mathrm{E}-4 \mathrm{~m}$ | Electrode length |
| w_e | w_f | 4E-6 m | Electrode width |
| I_P | l_p | $1.6 \mathrm{E}-5 \mathrm{~m}$ | Pad length |
| w_P | w_p | 8E-6 m | Pad width |
| r_an | $r_{-} a n$ | 3E-6 m | Anchor radius |
| t_e | tSi | 2E-6 m | Electrode thickness |
| t_an | t0x | $1.6 \mathrm{E}-6 \mathrm{~m}$ | Anchor thickness |
| n_e | n_f+1 | 22 | Number of electrodes |
| P_e | 3* (w_f+g_f) | $1.5 \mathrm{E}-5 \mathrm{~m}$ | Periodicity |
| x_e | $x_{-} f-w_{-} f-g_{-} f$ | $6.7 \mathrm{E}-5 \mathrm{~m}$ | x position |
| Y_e | w_PM/2+1_f-1_ovrlp | 6E-5 m | $y$ position |

4 In the Label text field, type Part Link: Sense Electrodes L.
5 Click Build All Objects.
6 Click the Wireframe Rendering button on the Graphics toolbar.

## Part Link: Sense Electrodes L I (pi5)

I Right-click Part Link: Sense Electrodes L and choose Duplicate.
2 In the Settings window for Part Instance, type Part Link: Sense Electrodes R in the Label text field.

3 Locate the Input Parameters section. In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| LH | 1 | I | 0: RH, I: LH |
| L_e | l_e_s | I.2E-4 m | Electrode length |
| x_e | $x_{-} f-2^{*}\left(w_{-} f+g_{-} f\right)$ | $62 \mu \mathrm{~m}$ | x position |

4 Click Build All Objects.
Part Link: Sense Electrodes R I (pi6)
I Right-click Component I (compI)>Geometry I>Part Link: Sense Electrodes R and choose Duplicate.

2 In the Settings window for Part Instance, type Part Link: Self Test Electrodes L 1 in the Label text field.

3 Locate the Input Parameters section. In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| LH | 0 | 0 | $0:$ RH, I: LH |
| n_e | n_st | 3 | Number of electrodes |
| P_e | $3 * w_{-} f+2 * g_{-} f+g_{-} s t$ | I.7E-5 $m$ | Periodicity |
| x_e | X_f $^{-2 *}\left(w_{-} f+g_{-} f\right)$ | $62 \mu \mathrm{~m}$ | x position |

4 Click Build All Objects.
5 In the table, enter the following settings:

| Name | Expression | Value |
| :--- | :--- | :--- |
| x_e | x_st-w_f-g_f | $5 E-6 \mathrm{~m}$ |

6 Click Build All Objects.

## Part Link: Self Test Electrodes L I.I (pi7)

I Right-click Component I (compI)>Geometry I>Part Link: Self Test Electrodes LI and choose Duplicate.

2 In the Settings window for Part Instance, type Part Link: Self Test Electrodes L 2 in the Label text field.

3 Locate the Input Parameters section. In the table, enter the following settings:

| Name | Expression | Value | Description |
| :---: | :---: | :---: | :---: |
| I_e | l_e_l | 140 mm | Electrode length |
| x_e | $\begin{aligned} & l_{-} P M-\left(x-s t+w_{-} f+g_{-} f\right) \\ & \left(n_{-} s t-1\right)^{*}\left(3^{*} w_{-} f+2^{*}\right. \\ & \left.g_{-} f+g_{-} s t\right)-w_{-} f \end{aligned}$ | $3.95 \mathrm{E}-4 \mathrm{~m}$ | x position |

4 Click Build All Objects.
Part Link: Self Test Electrodes L 2.1 (pi8)
I Right-click Component I (compI)>Geometry I>Part Link: Self Test Electrodes L 2 and choose Duplicate.

2 In the Settings window for Part Instance, type Part Link: Self Test Electrodes R 1 in the Label text field.

3 Locate the Input Parameters section. In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| LH | 1 | I | 0: RH, I: LH |
| x_e | $x_{-} s t-w_{-} f-g_{-} f+$ 2* $^{*}\left(w_{-} f+g_{-} f\right)$ | I.5E-5 m | x position |

4 Click Build All Objects.

## Part Link: Self Test Electrodes R I.I (pi9)

I Right-click Component I (compI)>Geometry I>Part Link: Self Test Electrodes R I and choose Duplicate.

2 In the Settings window for Part Instance, type Part Link: Self Test Electrodes R 2 in the Label text field.

3 Locate the Input Parameters section. In the table, enter the following settings:

| Name | Expression | Value | Description |
| :---: | :---: | :---: | :---: |
| I_e | l_e_s | 120 mm | Electrode length |
| x_e | $\begin{aligned} & l_{-P M-\left(x-s t+w_{-} f+g_{-} f\right)-}^{\left(n_{-} s t-1\right)^{*}\left(3^{*} w-f+2^{*}\right.} \\ & \left.g_{-} f+g_{-} s t\right)-w_{-} f+2^{*}\left(w_{-} f+\right. \\ & \left.g_{-} f\right) \end{aligned}$ | $4.05 \mathrm{E}-4 \mathrm{~m}$ | x position |

4 Click Build All Objects.
5 Click Go to Default View.

## Block I (blk I)

I On the Geometry toolbar, click Block.
2 In the Settings window for Block, type Air box in the Label text field.
3 Locate the Size and Shape section. In the Width text field, type l_polySi+40[um].
4 In the Depth text field, type hw_polySi+20[um].
5 In the Height text field, type 50 [um].
6 Locate the Position section. In the $\mathbf{x}$ text field, type -l_spAssm-20[um].
7 In the $\mathbf{z}$ text field, type - tox.
Air box (blkI)
I In the Model Builder window, under Component I (compl)>Geometry I click Air box (blkl).

2 In the Settings window for Block, click to expand the Layers section.
3 In the table, enter the following settings:

| Layer name | Thickness (m) |
| :--- | :--- |
| Layer 1 | t0x |
| Layer 2 | tSi |

4 Click Build All Objects.
5 In the Model Builder window, click Geometry I.
6 In the Settings window for Geometry, locate the Units section.
7 From the Length unit list, choose $\boldsymbol{\mu m}$.
8 In the Model Builder window, click Air box (blkI).
9 In the Settings window for Block, click Build All Objects.
IO Click Go to Default View.
Work Plane I (wpl)
I On the Geometry toolbar, click Work Plane.
2 In the Settings window for Work Plane, type Ground plane in the Label text field.
3 Locate the Plane Definition section. In the z-coordinate text field, type - tox.

## Plane Geometry

I In the Model Builder window, under Component I (compl)>Geometry I> Ground plane (wpI) click Plane Geometry.

2 Click the Zoom Extents button on the Graphics toolbar.

## Rectangle I (rl)

I On the Work Plane toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type l_PM.
4 In the Height text field, type w_PM/2+1_f.
5 Click Build Selected.
6 In the Model Builder window, click Geometry I.
Extrude I (extl)
I On the Geometry toolbar, click Extrude.
2 In the Settings window for Extrude, locate the Distances section.
3 In the table, enter the following settings:
Distances ( $\mu \mathrm{m}$ )
t0x
4 Click Build Selected.
Part Link: Proof mass (pil)
I In the Model Builder window, under Component I (compI)>Geometry I click Part Link: Proof mass (pil).

2 In the Settings window for Part Instance, click to expand the Domain selections section.
3 Locate the Domain Selections section. Click to select row number 1 in the table.
4 Click New Cumulative Selection.
5 In the New Cumulative Selection dialog box, type Polysilicon in the Name text field.
6 Click $\mathbf{O K}$.
7 In the Settings window for Part Instance, click to expand the Boundary selections section.
8 Locate the Boundary Selections section. Click New Cumulative Selection.
9 In the New Cumulative Selection dialog box, type Proof mass boundaries in the Name text field.

10 Click OK.
II In the Settings window for Part Instance, locate the Boundary Selections section.
12 Click to select row number 1 in the table.

13 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Proof Mass + Fingers Seq | csel2 |  | $\sqrt{ }$ |

Part Link: Spring I (pi2)
I In the Model Builder window, under Component I (compl)>Geometry I click Part Link: Spring I (pi2).

2 In the Settings window for Part Instance, locate the Domain Selections section.
3 Click to select row number 1 in the table.
4 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Spring + anchor | csell |  | $\sqrt{ }$ |

5 In the table, enter the following settings:

| Name | Contribute to | Keep |
| :--- | :--- | :--- |
| Spring + anchor | csel2 |  |

Part Link: Spring 2 (pi3)
I In the Model Builder window, under Component I (compI)>Geometry I click Part Link: Spring 2 (pi3).

2 In the Settings window for Part Instance, locate the Domain Selections section.
3 Click to select row number 1 in the table.
4 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Spring + anchor | csell |  | $\sqrt{ }$ |

5 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Spring + anchor | csel2 |  | $\sqrt{ }$ |

## Part Link: Sense Electrodes L (pi4)

I In the Model Builder window, under Component I (compI)>Geometry I click Part Link: Sense Electrodes L (pi4).
2 In the Settings window for Part Instance, locate the Domain Selections section.

3 Click to select row number 1 in the table.
4 In the table, enter the following settings:

| Name | Contribute to | Keep |
| :--- | :--- | :--- |
| Electrode array | csell |  |

5 Click New Cumulative Selection.
6 In the New Cumulative Selection dialog box, type Sense left boundaries in the Name text field.

7 Click OK.

## Part Link: Sense Electrodes R (pi5)

I In the Model Builder window, under Component I (compl)>Geometry I click
Part Link: Sense Electrodes R (pi5).
2 In the Settings window for Part Instance, locate the Domain Selections section.
3 Click to select row number 1 in the table.
4 In the table, enter the following settings:

| Name | Contribute to | Keep |
| :--- | :--- | :--- |
| Electrode array | csell | Physics |

5 Click New Cumulative Selection.
6 In the New Cumulative Selection dialog box, type Sense right boundaries in the Name text field.

7 Click OK.

## Part Link: Self Test Electrodes L I (pi6)

I In the Model Builder window, under Component I (compI)>Geometry I click Part Link: Self Test Electrodes LI(pi6).

2 In the Settings window for Part Instance, locate the Boundary Selections section.
3 Click New Cumulative Selection.
4 In the New Cumulative Selection dialog box, type Self test left boundaries in the Name text field.

5 Click OK.
6 In the Settings window for Part Instance, locate the Boundary Selections section.
7 Click to select row number 1 in the table.

8 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Electrode array | csel5 |  | $\sqrt{ }$ |

9 In the Model Builder window, expand the Component I (comp I)>Geometry I> Cumulative Selections node.

## GEOMETRY I

Part Link: Self Test Electrodes L 2 (pi7)
I In the Model Builder window, expand the Component I (compl)>Definitions node, then click Component I (compI)>Geometry I>Part Link: Self Test Electrodes L 2 (pi7).
2 In the Settings window for Part Instance, locate the Boundary Selections section.
3 Click to select row number 1 in the table.
4 Locate the Domain Selections section. Click to select row number 1 in the table.
5 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Electrode array | csell |  | $\sqrt{ }$ |

6 In the table, enter the following settings:

| Name | Contribute to | Keep |
| :--- | :--- | :--- |
| Electrode array | csel5 | Physics |

Part Link: Self Test Electrodes R I (pi8)
I In the Model Builder window, under Component I (compI)>Geometry I click Part Link: Self Test Electrodes R I (pi8).

2 In the Settings window for Part Instance, locate the Domain Selections section.
3 Click to select row number 1 in the table.
4 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Electrode array | csell |  | $\sqrt{ }$ |

5 Locate the Boundary Selections section. Click New Cumulative Selection.
6 In the New Cumulative Selection dialog box, type Self test right boundaries in the Name text field.

## 7 Click OK.

8 In the Settings window for Part Instance, locate the Boundary Selections section.
9 Click to select row number 1 in the table.
10 In the table, enter the following settings:

| Name | Contribute to | Keep |
| :--- | :--- | :--- |
| Electrode array | csel6 | Physics |

Part Link: Self Test Electrodes R 2 (pi9)
I In the Model Builder window, under Component I (compI)>Geometry I click Part Link: Self Test Electrodes R 2 (pi9).

2 In the Settings window for Part Instance, locate the Domain Selections section.
3 Click to select row number 1 in the table.
4 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Electrode array | csell |  | $\sqrt{ }$ |

5 In the table, enter the following settings:

| Name | Contribute to | Keep | Physics |
| :--- | :--- | :--- | :--- |
| Electrode array | csel6 |  | $\sqrt{ }$ |

Part Link: Self Test Electrodes L I (pi6)
I In the Model Builder window, under Component I (compI)>Geometry I click Part Link: Self Test Electrodes LI (pi6).
2 In the Settings window for Part Instance, locate the Domain Selections section.
3 Click to select row number 1 in the table.
4 In the table, enter the following settings:

| Name | Contribute to | Keep |
| :--- | :--- | :--- |
| Electrode array | csell | Physics |

Ground plane (wpl)
I In the Model Builder window, collapse the Component I (compl)>Geometry I> Ground plane (wpl) node.
2 In the Model Builder window, collapse the Component I (compI)>Geometry I> Cumulative Selections node.

## GEOMETRY I

In the Model Builder window, collapse the Component I (compl)>Geometry I node.

## DEFINITIONS

Box 1
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, locate the Geometric Entity Level section.
3 From the Level list, choose Boundary.
4 Locate the Box Limits section. In the $\mathbf{y}$ minimum text field, type -0.1.
5 In the $y$ maximum text field, type 0.1.
6 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.
7 In the Label text field, type Symmetry plane.
Box 2
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, type Anchor plane in the Label text field.
3 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
4 Locate the Box Limits section. In the $\mathbf{z}$ minimum text field, type -t0x*1.01.
5 In the $\mathbf{z}$ maximum text field, type $-\mathrm{t} 0 \mathrm{x} * 0.99$.
6 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

Box 3
I On the Definitions toolbar, click Box.
2 In the Settings window for Box, type Meshing plane in the Label text field.
3 Locate the Geometric Entity Level section. From the Level list, choose Boundary.
4 Locate the Box Limits section. In the $\mathbf{z}$ minimum text field, type -t0x*0.01.
5 In the $\mathbf{z}$ maximum text field, type $\mathrm{t} 0 \mathrm{x} * 0.01$.
6 Locate the Output Entities section. From the Include entity if list, choose Entity inside box.

## Thermoelastic Damping in a MEMS Resonator

## Introduction

High quality factor MEMS resonators are the key components in the emerging MEMS timing industry. In these applications a MEMS resonator is driven at its resonant frequency by a feedback loop to produce a circuit that oscillates at a fixed frequency. Such frequency references are used in a huge range of electronic devices, from CPU clocks to mobile phones. For oscillator applications the quality factor of the resonator, together with the stability of the resonant frequency, determines the ultimate performance achievable. Higher quality factor resonators have a sharper peak in their frequency spectrum at the resonant frequency and therefore pick out a particular frequency with higher fidelity. For many resonant modes the limit to the achievable quality factor is determined by thermoelastic damping.

To understand thermoelastic damping consider the stretching of a thermally isolated elastic rod. When such a rod is stretched uniformly and reversibly its temperature drops. The drop in temperature compensates for the increase in entropy caused by the stress in the rod (since the process is reversible the entropy remains constant). Similarly on compression the rod heats up. When a structure vibrates in a more complex normal mode there are some regions of compression and some of extension. Depending on the timescale of the vibration heat flows from the warmer parts of the structure to the cooler parts. Since heat flow is an irreversible process, this heat flow is associated with energy loss from the vibrational mode, and corresponding damping for the resonant mode. Thermoelastic damping is particularly important in smaller MEMS structures, in which regions of compression and expansion are in close proximity.

## Model Definition

The model consists of a single beam vibrating in its fundamental mode, perpendicular to its long axis. The model geometry is shown in Figure 1. The two ends of the beam are fixed and are assumed to be connected to a much larger body (for example a contact pad) which acts as a thermal reservoir.


Figure 1: Symmetric model geometry. The geometry consists of a silicon beam $12 \mu \mathrm{~m}$ thick and $400 \mu \mathrm{~m}$ long. The beam width is $20 \mu \mathrm{~m}$ but since the geometry is symmetric only half of the beam width is shown and the symmetry boundary conditions is used. The two ends of the beam are assumed to be clamped to a body with a large thermal mass, such as a contact pad.

This analysis computes the resonator quality factor, assuming that thermoelastic damping is the dominant damping mechanism. The coupled equations of thermoelasticity are solved within the resonator.

## DERIVATION OF THE THERMOELASTICITY EQUATIONS

References 1 to 7 provide useful background information.
The equations of thermoelasticity are derived from the first law of thermodynamics, which can be stated as follows:

$$
\begin{equation*}
d U=d Q^{\prime}+d W^{\prime} \tag{1}
\end{equation*}
$$

where $d U$ is the change in internal energy, $d Q$ ' is the heat flow into the system (the prime indicates an inexact differential in this case) and $d W^{\prime}$ is the work done on the system. For a small part of a solid (sufficiently small that the stresses and strains are uniform), with an initial reference density, $\rho_{0}$, the first law can be rewritten in the following form (assuming that the differential changes occur between equilibrium states):

$$
\begin{equation*}
d u=T_{a} d s+\frac{1}{\rho_{0}} \sigma: d \varepsilon \tag{2}
\end{equation*}
$$

where $T_{a}$ is the absolute temperature, $s$ is the entropy per unit mass, $\sigma$ is the elastic part of the second Piola-Kirchhoff stress (in general a rank 2 tensor), $\boldsymbol{\varepsilon}$ is the material strain
(also a tensor). In general the second Piola-Kirchhoff stress tensor, $\mathbf{p}$, must be split into elastic $(\boldsymbol{\sigma})$ and inelastic $(\boldsymbol{\tau})$ parts such that:

$$
\mathbf{p}=\sigma+\tau
$$

The elastic part of the stress tensor, $\sigma$, does work $\sigma: d \boldsymbol{d}$ during a change in the strain. The inelastic part of the strain tensor, $\tau$, generates heat at a rate $\tau:(d \boldsymbol{\varepsilon} / d \tau)$ when the strain is changing and is identified with internal or material damping. These internal damping mechanisms are associated with microscopic phenomena such as dislocation movement.

From Equation 2 it is possible to make the following identifications for $T_{a}$ and $\sigma$ :

$$
T_{a}=\left(\frac{\partial u}{\partial S}\right)_{\varepsilon} \quad \sigma=\rho_{0}\left(\frac{\partial u}{\partial \varepsilon}\right)_{S}
$$

Next the entropy balance equation must be derived. Because thermoelasticity involves irreversible processes, the assumption of equilibrium required to derive Equation 2 is no longer valid. Instead an assumption of 'local' equilibrium is made. It is assumed that although the system is not in equilibrium, there exists within small elements a state of local equilibrium, for which the local entropy per unit mass, $s$, is the same function of the internal energy, strain, and particle number as it was in equilibrium. This assumption is commonly employed in the modeling of transport phenomena and is justified only by the validity of conclusions derived from it and by results obtained from specific microscopic models, for near-equilibrium situations. For a small volume element in the material frame Equation 2 can then be written as

$$
\rho_{0} d s=\frac{1}{T_{a}} \rho_{0} d u-\frac{1}{T_{a}} \sigma: d \varepsilon
$$

The rate of change of entropy can then be written as

$$
\begin{equation*}
\rho_{0} \frac{d s}{d t}=\rho_{0} \frac{1}{T_{a}} \frac{d u}{d t}-\frac{1}{T_{a}} \sigma: \frac{d \varepsilon}{d t} \tag{3}
\end{equation*}
$$

From the first law (Equation 1) the rate of change of internal energy is given by:

$$
\rho_{0} \frac{d u}{d t}=\frac{d q}{d t}+\frac{d w}{d t}
$$

where $w$ is the work done per unit volume and $q$ is the heat accumulated per unit volume. The heat accumulated can be written as the sum of the heat sources and the divergence in the material frame heat flux:

$$
\frac{d q}{d t}=-(\nabla \cdot \mathbf{q})+Q+\tau: \frac{d \varepsilon}{d t}
$$

where $Q$ represents the heat source per unit volume and $\tau$ is the inelastic part of the stress tensor. The rate of doing work (per unit reference volume) by a linear elastic material is given by the elastic part of the second Piola-Kirchhoff stress contracted with the rate of material strain. Per unit volume the following equation is obtained:

$$
\frac{d w}{d t}=\sigma: \frac{d \varepsilon}{d t}
$$

so Equation 3 reduces to

$$
\rho_{0} \frac{d s}{d t}=-\frac{1}{T_{a}} \nabla \cdot \mathbf{q}+\frac{1}{T_{a}} Q+\frac{1}{T_{a}} \tau: \frac{d \varepsilon}{d t}
$$

The definition of the material thermal conductivity gives

$$
\mathbf{q}=-\kappa \nabla T_{a}
$$

where $\boldsymbol{\kappa}$ is the thermal conductivity, defined in the material frame.
Therefore the equation is

$$
\begin{equation*}
T_{a} \rho_{0} \frac{d s}{d t}=\nabla \cdot\left(\kappa \nabla T_{a}\right)+Q+\tau: \frac{d \varepsilon}{d t} \tag{4}
\end{equation*}
$$

It is now necessary to derive an expression for the rate of change of entropy with respect to time. In order to do this an assumption of local equilibrium is used once again. Using Equation 2 the equation is written

$$
d\left(u-T_{a} s-\frac{1}{\rho_{0}} \sigma: \varepsilon\right)=-s d T_{a}-\frac{1}{\rho_{0}} \varepsilon: d \sigma
$$

which defines a new thermodynamic potential, the Gibbs free energy per unit mass, given by

$$
g=u-T_{a} s+\frac{1}{\rho_{0}} \sigma: \varepsilon
$$

Changes in the Gibbs free energy per unit mass take the form

$$
d g=-s d T_{a}-\frac{1}{\rho_{0}} \varepsilon: d \boldsymbol{\sigma}
$$

which leads to the relations

$$
s=-\left(\frac{\partial g}{\partial T_{a}}\right) \sigma \quad \varepsilon=-\rho_{0}\left(\frac{\partial g}{\partial \sigma}\right)_{T_{a}}
$$

By differentiating each of the above equations a second time, it is possible to derive the following Maxwell relation

$$
\begin{equation*}
\left(\frac{\partial s}{\partial \sigma}\right)_{T_{a}}=\frac{1}{\rho_{0}}\left(\frac{\partial \varepsilon}{\partial T_{a}}\right)_{\sigma}=-\frac{\partial^{2} g}{\partial \sigma \partial T_{a}} \tag{5}
\end{equation*}
$$

It is now possible to derive an expression for the entropy of the solid. Assuming that the elastic stress is an invertible function of the strain, we can write $s=s\left(\sigma, T_{a}\right)$. Thus,

$$
d s=\left(\frac{\partial s}{\partial \sigma}\right)_{T_{a}}: \mathrm{d} \boldsymbol{\sigma}+\left(\frac{\partial s}{\partial T_{a}}\right)_{\sigma} d T_{a}
$$

Using the Maxwell relation in Equation 5 gives

$$
d s=\frac{1}{\rho_{0}}\left(\frac{\partial \varepsilon}{\partial T_{a}}\right): \mathrm{d} \sigma+\left(\frac{\partial s}{\partial T_{a}}\right)_{\sigma} d T_{a}
$$

so that

$$
\frac{d s}{d t}=\frac{1}{\rho_{0}}\left(\frac{\partial \varepsilon}{\partial T_{a}}\right):: \frac{d \boldsymbol{\sigma}}{d t}+\left(\frac{\partial s}{\partial T_{a}}\right) \frac{d T_{a}}{\sigma}
$$

By definition the heat capacity of the solid at constant stress is given by

$$
c_{p}=\left(\frac{\partial q}{\partial T}\right)_{\boldsymbol{\sigma}}=T_{a}\left(\frac{\partial s}{\partial T}\right)_{\boldsymbol{\sigma}}
$$

Thus,

$$
\begin{equation*}
\frac{d s}{d t}=\frac{1}{\rho_{0}}\left(\frac{\partial \varepsilon}{\partial T_{a}}\right): \frac{d \sigma}{d t}+\frac{c_{p}}{T_{a}} \frac{d T_{a}}{d t} \tag{6}
\end{equation*}
$$

Substituting Equation 6 into Equation 4 gives the following equation for thermoelasticity:

$$
\begin{equation*}
\rho_{0} c_{p} \frac{d T_{a}}{d t}=\nabla \cdot\left(\kappa \nabla T_{a}\right)+Q+\tau: \frac{d \varepsilon}{d t}-T_{a}\left(\frac{\partial \varepsilon}{\partial T_{a}}\right): \frac{d \boldsymbol{\sigma}}{d t} \tag{7}
\end{equation*}
$$

An additional heat source term is present in Equation 7, compared to the standard heat transfer equations in solids. This term couples the structural problem with the heat transfer problem. In turn the heat transfer equation couples back into the structural problem through the constitutive relationship. COMSOL solves a linearized form of the anisotropic thermoelasticity equations given in Equation 7.

In the particular case of a linear elastic material (in the absence of damping) the stress and strain are related by Duhamel-Hooke's law:

$$
\left(\boldsymbol{\sigma}-\boldsymbol{\sigma}_{i}\right)=\mathbf{C}:\left(\varepsilon-\varepsilon_{i}-\boldsymbol{\alpha}\left(T_{a}-T_{r e f}\right)\right)
$$

where $\mathbf{C}$ is the elasticity tensor, $\boldsymbol{\sigma}_{i}$ is the initial stress, $\boldsymbol{\varepsilon}_{i}$ is the initial strain and $T_{r e f}$ is the reference temperature at which the strain and stresses take the initial values.

This equation couples the heat transfer equation to the structural problem. Given a temperature independent thermal expansivity, and no material damping, Equation 7 takes the form

$$
\rho_{0} c_{p} \frac{d T_{a}}{d t}=\nabla \cdot\left(\kappa \nabla T_{a}\right)+Q-T_{a} \alpha: \frac{d \sigma}{d t}
$$

which is the usual form of the equation for linear thermoelasticity.

## Results and Discussion

Figure 2 shows the mode shape and the corresponding temperature distribution within the beam. The mode has an eigenfrequency of 63.3 kHz and a quality factor of 10700 . In Ref. 4 Zener derived an approximate analytic expression for the quality factor of a thin isotropic beam vibrating in its fundamental mode, by considering only the thermal gradients in the direction of flexure. Zener's expression is given by:

$$
\begin{equation*}
\frac{1}{Q}=\frac{E \alpha T_{a}}{\rho_{0} c_{p}} \frac{\omega \tau}{1+(\omega \tau)^{2}} \tag{8}
\end{equation*}
$$

where $E$ is the Young's modulus of the beam, $\alpha$ is the isotropic thermal expansivity, $\omega$ is the mechanical angular resonant frequency and $\tau$ is the thermal relaxation time constant of the system, given by:

$$
\tau=\frac{\rho_{0} c_{p} h^{2}}{\pi^{2} \kappa}
$$

where $h$ is the beam thickness and $\kappa$ is the thermal conductivity of the mode. The resonant frequency of the beam can also be computed analytically and is given by:

$$
\begin{equation*}
\omega=22,373 \frac{h}{L^{2}} \sqrt{\frac{E}{12 \rho_{0}}} \tag{9}
\end{equation*}
$$

Table 1 compares the COMSOL model with values computed using Equation 8 and Equation 9 and with experimental results, obtained from Ref. 7. Note that the COMSOL model has a slightly higher quality factor than the theoretical result, because some of the thermal gradients are removed by the isothermal boundary condition (the quality factor is reduced significantly if a thermal insulation boundary condition is applied to the end boundaries-in practice the real boundary condition is somewhere between these two extremes).

Eigenfrequency $=6.327 \mathrm{E} 5 \mathrm{~Hz}$ Surface: Temperature deviation (K)


Figure 2: Fundamental mode shape and corresponding temperature distribution within the beam.

TABLE I: COMPARISON OF RESULTS FROM THE MODEL WITH THEORY AND EXPERIMENT

| SOURCE | RESONANT FREQUENCY $(M H Z)$ | QUALITY FACTOR |
| :--- | :--- | :--- |
| COMSOL Model | 0.63 | $10.7 \times 10^{3}$ |

TABLE I: COMPARISON OF RESULTS FROM THE MODEL WITH THEORY AND EXPERIMENT

| SOURCE | RESONANT FREQUENCY (MHZ) | QUALITY FACTOR |
| :--- | :--- | :--- |
| Equation 8 and <br> Equation 9 | 0.63 | $10.3 \times 10^{3}$ |
| Experiment (Ref. 7) | 0.57 | $10.3 \times 10^{3}$ |

## References

1. C.J. Adkins, Equilibrium Thermodynamics, Cambridge University Press, 1983.
2. W. Yourgrau, A. van der Merwe, and G. Raw, Treatise on Irreversible and Statistical Thermodynamics: An Introduction to Nonclassical Thermodynamics, Dover Publications, Inc., New York, 2002.
3. C. Zener, "Internal Friction in Solids I: Theory of Internal Friction in Reeds," Physical Review, vol. 52, pp. 90-99, 1937.
4. C. Zener, "Internal Friction in Solids II: General Theory of Thermoelastic Internal Friction," Physical Review, vol. 53, pp. 230-235, 1938.
5. M. E. Gurtin, E. Fied, and L. Anand, The Mechanics and Thermodynamics of Continua, Cambridge University Press, 2010.
6. V.A. Lubarda, "On Thermodynamic Potentials in Linear Thermoelasticity," Int. J.

Solids and Structures, vol. 41, no. 26, pp. 7377-7398, 2004.
7. A. Duwel, R.N. Candler, T.W. Kenny, and M. Varghese, "Engineering MEMS

Resonators with Low Thermoelastic Damping," J. Microelectromechanical Systems, vol. 15, no. 6, pp. 1437-1445, 2006.

Application Library path: MEMS_Module/Actuators/thermoelastic_damping_3d

## Modeling Instructions

From the File menu, choose New.

## N E W

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Thermoelasticity (te).
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies>Eigenfrequency.
6 Click Done.

## GEOMETRY I

Block I (blk I)
I On the Geometry toolbar, click Block.
2 In the Settings window for Block, locate the Size and Shape section.
3 In the Width text field, type 4e-4.
4 In the Depth text field, type 1.2e-5.
5 In the Height text field, type 1.2e-5.
6 In the Width text field, type 4e-4.
7 Click Build All Objects.

## GLOBAL DEFINITIONS

## Parameters

I On the Home toolbar, click Parameters.
2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| E0 | $157[\mathrm{GPa}]$ | 1.57 EII Pa | Young's modulus |
| rho0 | $2330\left[\mathrm{~kg} / \mathrm{m}^{\wedge} 3\right]$ | $2330 \mathrm{~kg} / \mathrm{m}^{3}$ | Density |
| nu0 | 0.3 | 0.3 | Poisson's ratio |
| alpha0 | $2.6 \mathrm{e}-6[1 / \mathrm{K}]$ | $2.6 \mathrm{E}-6 \mathrm{I} / \mathrm{K}$ | Coefficient of thermal <br> expansion |
| Cp0 | $700[\mathrm{~J} /(\mathrm{kg} * \mathrm{~K})]$ | $700 \mathrm{~J} /(\mathrm{kg} \cdot \mathrm{K})$ | Heat capacity |
| kappa0 | $90[\mathrm{~W} /(\mathrm{m} * \mathrm{~K})]$ | $90 \mathrm{~W} /(\mathrm{m} \cdot \mathrm{K})$ | Thermal conductivity |

## MATERIALS

## Material I (matl)

I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.

2 In the Settings window for Material, locate the Material Contents section.
3 In the table, enter the following settings:

| Property | Name | Value | Unit | Property <br> group |
| :--- | :--- | :--- | :--- | :--- |
| Young's modulus | E | E0 | Pa | Basic |
| Poisson's ratio | nu | nu0 | I | Basic |
| Density | rho | $\mathrm{rho0}$ | $\mathrm{~kg} / \mathrm{m}^{3}$ | Basic |
| Coefficient of thermal <br> expansion | alpha | $\mathrm{alpha0}$ | $\mathrm{I} / \mathrm{K}$ | Basic |
| Thermal conductivity | k | $\mathrm{kappa0}$ | $\mathrm{~W} /(\mathrm{m} \cdot \mathrm{K})$ | Basic |
| Heat capacity at constant <br> pressure | Cp | CpO | $\mathrm{J} /(\mathrm{kg} \cdot \mathrm{K})$ | Basic |

THERMOELASTICITY (TE)

## Symmetry I

I In the Model Builder window, under Component I (compl) right-click Thermoelasticity (te) and choose the boundary condition Solid Mechanics>Symmetry.

2 Select Boundary 2 only.

## Fixed Constraint I

I In the Model Builder window, right-click Thermoelasticity (te) and choose the boundary condition Solid Mechanics>Fixed Constraint.

2 Select Boundaries 1 and 6 only.

## Zero Temperature Deviation I

I Right-click Thermoelasticity (te) and choose Zero Temperature Deviation.
2 Select Boundaries 1 and 6 only.

## MESH I

## Mapped I

I In the Model Builder window, under Component I (compl) right-click Mesh I and choose More Operations>Mapped.

2 Select Boundary l only.

## Distribution I

I Right-click Component I (comp I)>Mesh I>Mapped I and choose Distribution.
2 Select Edges 4 and 6 only.

## Distribution I

I In the Model Builder window, right-click Mesh I and choose Swept.
2 Right-click Swept I and choose Distribution.
3 In the Settings window for Distribution, locate the Distribution section.
4 In the Number of elements text field, type 70.
5 Click Build AII.


## STUDY I

## Step I: Eigenfrequency

I In the Settings window for Eigenfrequency, locate the Study Settings section.
2 Select the Desired number of eigenfrequencies check box.
3 In the associated text field, type 1.
4 Select the Search for eigenfrequencies around check box.
5 In the associated text field, type 0.63 e 6.
6 From the Eigenfrequency search method around shift list, choose Larger real part.
7 On the Home toolbar, click Compute.

## RESULTS

## Temperature Deviation (te)

I In the Model Builder window, under Results click Temperature Deviation (te).
2 On the Temperature Deviation (te) toolbar, click Plot.
Compare the default plot with .

## Global Evaluation I

I On the Results toolbar, click Global Evaluation.
2 In the Settings window for Global Evaluation, click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Component I> Thermoelasticity>Global>te.Q_eig - Quality factor for eigenvalue.

3 Click Evaluate.
Compare the result with that in .

## Thickness Shear Mode Quartz Oscillator

## Introduction

AT cut quartz crystals are widely employed in a range of applications, from oscillators to microbalances. One of the important properties of the AT cut is that the resonant frequency of the crystal is temperature independent to first order. This is desirable in both mass sensing and timing applications. AT cut crystals vibrate in the thickness shear mode - an applied voltage across the faces of the cut produces shear stresses inside the crystal. This example considers the vibration of an AT cut thickness shear oscillator, focusing on the mechanical response of the system in the frequency domain. The effect of a series capacitor on the mechanical resonance is also considered. Adding a series capacitance is a technique frequently employed to tune crystal oscillators.

## Model Definition

The model geometry is shown in Figure 1. The oscillator consists of a single (left-handed) quartz disc, supported so as not to impede the motion of the vibrational mode. There are two electrodes on the top and bottom surfaces of the geometry, one of which is grounded.


Figure 1: Model geometry.
In the first version of the model an AC voltage is applied to the top electrode. In the second version, the crystal is still driven by an AC voltage, but a capacitor is placed between the voltage source and the top electrode of the crystal.

## DOMAIN LEVEL EQUATIONS

Within a piezoelectric crystal there is a coupling between the strain and the electric field, which is determined by the constitutive relation:

$$
\begin{align*}
& \mathbf{T}=c_{E} \mathbf{S}-e^{T} \mathbf{E}  \tag{1}\\
& \mathbf{D}=e \mathbf{S}+\varepsilon_{S} \mathbf{E}
\end{align*}
$$

Here, $\mathbf{S}$ is the strain, $\mathbf{T}$ is the stress, $\mathbf{E}$ is the electric field, and $\mathbf{D}$ is the electric displacement field. The material parameters $c_{E}, e$, and $\varepsilon_{S}$, correspond to the material stiffness, the coupling properties, and the permittivity. These quantities are tensors of rank 4,3 , and 2 respectively, but, since the tensors are highly symmetric for physical reasons, they can be represented as matrices within an abbreviated subscript notation, which is usually more convenient. Equation 1 is implemented by the Piezoelectric Effect branch located under the Multiphysics branch. This constitutive relation is used to couple the equations of Solid Mechanics and Electrostatics, which are solved within the material.

## MATERIAL ORIENTATION

The orientation of a piezoelectric crystal cut is frequently defined by the system introduced by the IRE standard of 1949 (Ref. 1). This standard has undergone a number of subsequent revisions, with the final revision being the IEEE standard of 1987 (Ref. 2). Unfortunately the 1987 standard contained a number of serious errors and the IEEE subsequently withdrew it. COMSOL Multiphysics therefore adopts the preceding 1978 standard (Ref. 3), which is similar to the 1987 standard, for material property definitions. Most of the material properties in the material library are based on the values given in the book by Auld (Ref. 4), which uses the 1978 IEEE conventions. This is consistent with general practice except in the specific case of Quartz, where it is more common to use the 1949 IRE standard to define the material properties. COMSOL Multiphysics therefore provides an additional set of material properties consistent with the 1949 standard for the case of Quartz. Note that the material properties for quartz are based on Ref. 5, which uses the 1949 IRE standard (the properties are appropriately modified according to the different standards).

The stiffness, compliance, coupling, and dielectric material property matrices are defined with the crystal axes aligned with the local coordinate axes. Note that the signs of several matrix components differ between the IRE 1949 and the IEEE 1978 standards (see Table 1). In the absence of a user-defined coordinate system, the local system corresponds to the global $X, Y$, and $Z$ coordinate axes. When an alternative coordinate system is selected this system defines the orientation of the crystal axes. This is the mechanism used in COMSOL Multiphysics to define a particular crystal cut, and typically it is necessary to calculate the appropriate Euler angles for the cut (given the thickness orientation for the wafer). All piezoelectric material properties are defined using the Voigt form of the abbreviated subscript notation, which is universally employed in the literature (this differs from the standard notation used for Linear Elastic Material in the Solid Mechanics
interface). The material properties are defined in the material frame, so that if the solid rotates during deformation the material properties rotate with the solid.

Crystal cuts are usually defined by a mechanism introduced by the IEEE/IRE standards. Both standards use a notation that defines the orientation of a virtual slice (the plate) through the crystal. The crystal axes are denoted $X, Y$, and $Z$ and the plate, which is usually rectangular, is defined as having sides $l, w$, and $t$ (length, width, and thickness). Initially the plate is aligned with respect to the crystal axes and then up to three rotations are defined, using a right-handed convention about axes embedded along the $l, w$, and $t$ sides of the plate. This model uses AT cut quartz, defined in the IEEE 1978 standard as: $(Y X l)$ $-35.25^{\circ}$. The first two letters in the bracketed expression always refer to the initial orientation of the thickness and the length of the plate. Subsequent bracketed letters then define up to three rotational axes, which move with the plate as it is rotated. Angles of rotation about these axes are specified after the bracketed expression in the order of the letters, using a right-handed convention. For AT cut quartz only one rotation, about the $l$ axis, is required. This is illustrated in Figure 2. Note that within the 1949 IRE Standard AT cut quartz is denoted as: $(Y X l)+35.25^{\circ}$. Table 2 summarizes the differences between the standards for the AT cut.

When defining the material properties of Quartz, the orientation of the $X, Y$, and $Z$ axes with respect to the crystal differs between the 1978 IEEE standard and the 1949 IRE standard. A consequence of this is that both
! the material property matrices and the crystal cuts differ between the two standards. Table 1 summarizes the signs for the important matrix elements under the two conventions. Table 2 shows the different definitions of the crystal cuts under the two conventions.

TABLE I: SIGNS FOR THE MATERIAL PROPERTIES OF QUARTZ, WITHIN THE TWO STANDARDS COMMONLY EMPLOYED

|  | IRE 1949 STANDARD |  | IEEE I978 STANDARD |  |
| :--- | :--- | :--- | :--- | :--- |
| MATERIAL <br> PROPERTY | RIGHT HANDED <br> QUARTZ | LEFT HANDED <br> QUARTZ | RIGHT HANDED <br> QUARTZ | LEFT HANDED <br> QUARTZ |
| $s_{14}$ | + | + | - | - |
| $c_{14}$ | - | - | + | + |
| $d_{11}$ | - | + | + | - |
| $d_{14}$ | - | + | - | + |
| $e_{11}$ | - | + | + | - |
| $e_{14}$ | + | - |  | - |

TABLE 2: CRYSTAL CUT DEFINITIONS FOR QUARTZ CUTS WITHIN THE TWO STANDARDS COMMONLY EMPLOYED AND THE CORRESPONDING EULER ANGLES FOR DIFFERENT ORIENTATIONS OF THE CRYSTAL THICKNESS

| STANDARD | REPRESENTATION | AT CUT |
| :--- | :--- | :--- |
| IRE I949 | Standard | $(Y X l)+35.25^{\circ}$ |
|  | Y-thickness Euler angles | $\left(Z X Z: 0^{\circ},-35.25^{\circ}, 0^{\circ}\right)$ |
|  | Z-thickness Euler angles | $\left(\mathrm{ZXZ:} 0^{\circ},-125.25^{\circ}, 0^{\circ}\right)$ |
| IEEE 1978 | Standard | $(Y X l)-35.25^{\circ}$ |
|  | Y-thickness Euler angles | $\left(Z X Z: 0^{\circ}, 35.25^{\circ}, 0^{\circ}\right)$ |
|  | Z-thickness Euler angles | $\left(Z X Z: 0^{\circ},-54.75^{\circ}, 0^{\circ}\right)$ |

When defining the material orientation it is necessary to consider the orientation of the plate with respect to the global coordinate system in addition to the orientation of the plate with respect to the crystallographic axes.

This model uses AT cut quartz, defined in the IEEE 1978 standard as shown in Figure 2. The definition of the appropriate local coordinate system depends on the desired final orientation of the plate in the global coordinate system. One way to set up the plate is to orientate its normal parallel to the $Y$ axis in the global coordinate system. Figure 3 shows how to define the local coordinate system in this case (instructions for how to set up the crystal in this manner are provided in brackets in the step by step instructions).

Figure 4 shows how to define the local system such that the plate has its normal parallel to the global $Z$ axis, which is the case for the crystal in this model.

Whatever crystal orientation is chosen, it is critical to keep track of the orientation of the local system with respect to the global system, which is defined depending on the desired orientation of the plate in the model.

There are also a number of methods to define the local coordinate system with respect to the global system. Usually it is most convenient to define the local coordinates with a Rotated System node, which defines three Euler angles according to the ZXZ convention (rotation about Z , then X , then Z again). Note that these Euler angles define the local (crystal) axes with respect to the global axes - this is distinct from the approach of
defining the cut (global) axes with respect to the crystal (local) axes.


Figure 2: Definition of the AT cut of quartz within the IEEE 1978 standard. The AT cut is defined as: $(Y X l)-35.25^{\circ}$. The first two bracketed letters specify the initial orientation of the plate, with the thickness direction, $t$, along the crystal $Y$ axis and the length direction, $l$, along the $X$ axis. Then up to three rotations about axes that move with the plate are specified by the corresponding bracketed letters and the subsequent angles. In this case only one rotation is required about the $l$ axis, of $-35.25^{\circ}$ (in a right-banded sense).


Figure 3: Defining an AT cut crystal plate within COMSOL Multiphysics, with normal in the global Y-direction. Within the 1978 IEEE standard the AT cut is defined as (YXl) $35.25^{\circ}$. Start with the plate normal or thickness in the $Y_{\text {cr }}$ direction (a) and rotate the plate $-35.25^{\circ}$ about the l axis (b). The global coordinate system rotates with the plate. Finally rotate the entire system so that the global coordinate system is orientated as it appears in COMSOL Multiphysics (c). The local coordinate system should be defined with the Euler angles (ZXZ $\left.0,35.25^{\circ}, 0\right)$.(d) shows a coordinate system for this system in COMSOL Multiphysics.

e)



Figure 4: Defining an AT cut crystal plate within COMSOL Multiphysics, with normal in the global Z-direction. Within the 1978 IEEE standard the AT cut is defined as (YXl) $35.25^{\circ}$. Begin with the plate normal in the $Z_{c r}$-direction, so the crystal and global systems are coincident. Rotate the plate so that its thickness points in the $Y_{c r}$-direction (the starting point for the IEEE definition), the global system rotates with the plate (b). Rotate the plate $-35.25^{\circ}$ about the $l$ axis (d). Finally rotate the entire system so that the global coordinate system is orientated as it appears in COMSOL Multiphysics (d). The local coordinate system should be defined with the Euler angles ( $\left.Z X Z: 0,-54.75^{\circ}, 0\right)$. (e) shows a coordinate system for this system in COMSOL Multiphysics.

## ELECTRICAL CIRCUIT

In the first part of the model an AC voltage is applied directly to the top plate of the oscillator, which is grounded. In the second part of the model, a capacitor is added between the voltage source and the oscillator, as shown in Figure 5. In COMSOL Multiphysics, the oscillator is coupled into the circuit using the External I Terminal feature. The terminal boundary condition within the model is set to Circuit and this feature then captures the charge generated by the circuit.


Figure 5: Top left: Electrical circuit for the first part of the model. Top right: Electrical circuit for the second part of the model. Bottom: Circuit for the second part of the model as implemented in COMSOL Multiphysics.

## Results and Discussion

Figure 6 shows the crystal displacement at its resonant frequency of 5.11 MHz . The form of the displacement shows clearly the shear nature of the resonance. The potential on cut slices through the plate is illustrated in Figure 7. The mechanical domain frequency response of the oscillator is shown in Figure 8. A clear anti-resonance is apparent, with a resonant frequency close to 5.11 MHz .

The addition of a series capacitance between the oscillator and the voltage source is expected to pull the resonant frequency to higher values. Figure 9 shows that this effect occurs as expected, with the resonant frequency increasing the most for smaller values of the series capacitance (in the limit of very large series capacitance the impedance of the series capacitor goes to zero and produces the result shown in Figure 8).
freq(18) $=5112000 \mathrm{~Hz}$ Surface: Total displacement (nm)


Figure 6: Displacement of the crystal at resonance.
freq $(18)=5112000 \mathrm{~Hz}$ Multislice: Electric potential (V)


Figure 7: Electric potential inside the crystal at resonance.


Figure 8: Mechanical response of the structure with no series capacitance.


Figure 9: Mechanical response of the structure with different series capacitances.

## References

1. "Standards on Piezoelectric Crystals, 1949", Proceedings of the I. R. E.,vol. 37, no.12, pp. 1378-1395, 1949.
2. IEEE Standard on Piezoelectricity, ANSI/IEEE Standard 176-1987, 1987.
3. IEEE Standard on Piezoelectricity, ANSI/IEEE Standard 176-1978, 1978.
4. B. A. Auld, Acoustic Fields and Waves in Solids, Krieger Publishing Company, 1990.
5. R. Bechmann, "Elastic and Piezoelectric Constants of Alpha-Quartz", Physical Review $B$, vol. 110 no. 5, pp. 1060-1061, 1958.

Application Library path: MEMS_Module/Piezoelectric_Devices/
thickness_shear_quartz_oscillator

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 3D.
2 In the Select Physics tree, select Structural Mechanics>Piezoelectric Devices.
3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces> Frequency Domain.

6 Click Done.

## GLOBAL DEFINITIONS

Add parameters for the model geometry and series capacitance.

## Parameters

I On the Home toolbar, click Parameters.

2 In the Settings window for Parameters, locate the Parameters section.
3 In the table, enter the following settings:

| Name | Expression | Value | Description |
| :--- | :--- | :--- | :--- |
| Cs | $1[\mathrm{pF}]$ | IE-I2 F | Series capacitance |
| R0 | $835[\mathrm{um}]$ | $8.35 \mathrm{E}-4 \mathrm{~m}$ | Oscillator radius |
| H0 | $334[\mathrm{um}]$ | $3.34 \mathrm{E}-4 \mathrm{~m}$ | Oscillator thickness |

## GEOMETRY I

Create the geometry.
Cylinder I (cyll)
I On the Geometry toolbar, click Cylinder.
2 In the Settings window for Cylinder, locate the Size and Shape section.
3 In the Radius text field, type RO.
4 In the Height text field, type HO.
If you wish to set up the material orientation using the alternative method shown in , change the Axis type to $y$-axis.

5 Click Build All Objects.

## DEFINITIONS

Set up a rotated system appropriate for AT cut Quartz.

## Rotated System 2 (sys2)

I On the Definitions toolbar, click Coordinate Systems and choose Rotated System.
2 In the Settings window for Rotated System, locate the Settings section.
3 Find the Euler angles (Z-X-Z) subsection. In the $\beta$ text field, type -54.75 [deg].
If you wish to set up the material orientation using the alternative method shown in , type 35.25 [deg] in the $\beta$ text field.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select Piezoelectric>Quartz LH (1978 IEEE).
4 Click Add to Component in the window toolbar.

## MATERIALS

Quartz LH (I978 IEEE) (matl)
On the Home toolbar, click Add Material to close the Add Material window.

## SOLID MECHANICS (SOLID)

Use the rotated system to define the orientation of the crystal.

## Piezoelectric Material I

I In the Model Builder window, under Component I (comp I)>Solid Mechanics (solid) click Piezoelectric Material I.

2 In the Settings window for Piezoelectric Material, locate the Coordinate System Selection section.

3 From the Coordinate system list, choose Rotated System 2 (sys2).
Add damping to the model.

## Mechanical Damping I

I Right-click Component I (compl)>Solid Mechanics (solid) $>$ Piezoelectric Material I and choose Damping.

2 In the Settings window for Mechanical Damping, locate the Damping Settings section.
3 From the Damping type list, choose Isotropic loss factor.
4 From the $\eta_{\mathrm{s}}$ list, choose User defined. In the associated text field, type 1e-3.

## ELECTROSTATICS <br> (ES)

Add electrical boundary conditions to the model. First add a Terminal boundary condition that connects the electrode to an external circuit.

## Terminal I

I In the Model Builder window, under Component I (compl) right-click Electrostatics (es) and choose the boundary condition Terminal.

2 Select Boundary 4 only.
3 In the Settings window for Terminal, locate the Terminal section.
4 From the Terminal type list, choose Circuit.
Over-ride the preceding boundary condition with a constant potential boundary condition to compute the response of the device without a series capacitance. This node will be disabled in the study when the circuit is included in the model.

## Terminal 2

I In the Model Builder window, right-click Electrostatics (es) and choose the boundary condition Terminal.

2 In the Settings window for Terminal, locate the Terminal section.
3 In the Terminal name text field, type 1.
4 Select Boundary 4 only.
5 From the Terminal type list, choose Voltage.
6 In the $V_{0}$ text field, type 10.

## Ground I

I Right-click Electrostatics (es) and choose Ground.
2 Select Boundary 3 only.
ROOT
In the second study in this model, the effect of a series capacitor on the device response will be investigated. Add an Electrical Circuit interface to model the capacitor.

## ADD PHYSICS

I On the Home toolbar, click Add Physics to open the Add Physics window.
2 Go to the Add Physics window.
3 In the tree, select AC/DC>Electrical Circuit (cir).
4 Click Add to Component in the window toolbar.
5 On the Home toolbar, click Add Physics to close the Add Physics window.

## ELECTRICAL CIRCUIT (CIR)

Features in the Electric Circuits interface are connected by specifying connecting node numbers for each port of the device.

## Ground Node I

A ground node is automatically added to the circuit, with the default node number of 0 .
Next add a voltage source between the ground node and a (newly created) node with number 2.

Voltage Source VI
I In the Model Builder window, right-click Electrical Circuit (cir) and choose Voltage Source.
2 In the Settings window for Voltage Source, locate the Node Connections section.

3 In the table, enter the following settings:

| Label | Node names |
| :--- | :--- |
| P | 2 |
| n | 0 |

4 Locate the Device Parameters section. From the Source type list, choose AC-source.
5 In the $V_{\text {src }}$ text field, type 10.
Add a capacitor between the voltage source output (node 2 ) and a new node, 1 .

## Capacitor CI

I Right-click Electrical Circuit (cir) and choose Capacitor.
2 In the Settings window for Capacitor, locate the Node Connections section.
3 In the table, enter the following settings:

| Label | Node names |
| :--- | :--- |
| P | 2 |
| n | 1 |

4 Locate the Device Parameters section. In the $C$ text field, type Cs.
Connect node 1 to the Terminal feature in the model using the External I-Terminal feature.

## External I-Terminal I

I Right-click Electrical Circuit (cir) and choose External Couplings>External I-Terminal. Couple the electric potential from the Terminal in the electrostatics interface back into the model.

2 In the Settings window for External I-Terminal, locate the Node Connections section.
3 In the Node name text field, type 1.
4 Locate the External Terminal section. From the $V$ list, choose Terminal voltage (es).

## MESH I

Create a swept triangular mesh.

## Free Triangular I

I In the Model Builder window, under Component I (comp I) right-click Mesh I and choose More Operations>Free Triangular.

2 Select Boundary 4 only.

## Distribution I

I In the Model Builder window, right-click Mesh I and choose Swept.

## 2 Right-click Swept I and choose Distribution.

3 In the Settings window for Distribution, locate the Distribution section.
4 In the Number of elements text field, type 4.

## 5 Click Build AlI.



The mesh used here is somewhat coarse for the range of frequencies that are solved for. This is mainly to keep the computational time and RAM requirements as low as possible. Interested users are encouraged to solve the problem for finer mesh settings.

## STUDY I

Set up and solve a frequency dependent study.

## Step I: Frequency Domain

I In the Model Builder window, under Study I click Step I: Frequency Domain.
2 In the Settings window for Frequency Domain, locate the Study Settings section.

## 3 Click Range.

4 In the Range dialog box, type $5.095[\mathrm{MHz}]$ in the Start text field.
5 In the Step text field, type $1[\mathrm{kHz}]$.

6 In the Stop text field, type $5.13[\mathrm{MHz}]$.

## 7 Click Replace.

In the first study, disable the electrical circuit.
8 In the Settings window for Frequency Domain, locate the Physics and Variables Selection section.

9 In the table, clear the Solve for check box for the Electrical Circuit (cir) interface.
10 On the Home toolbar, click Compute.

## RESULTS

Instead of the stress plot, visualize the mode shape of the device at resonance. Note that this plot and subsequent plots will appear rotated compared to that shown in if the alternative definition of the material orientation described in is used.

## Stress (solid)

I In the Model Builder window, under Results click Stress (solid).
2 In the Settings window for 3D Plot Group, type Displacement in the Label text field.
3 Locate the Data section. From the Parameter value (freq (Hz)) list, choose 5.II2E6.

## Surface I

I In the Model Builder window, expand the Results>Displacement node, then click Surface I.

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>solid.disp - Total displacement.

3 Locate the Expression section. From the Unit list, choose nm.
4 Click the Zoom Extents button on the Graphics toolbar.
5 On the Displacement toolbar, click Plot.
The second default plot shows the electric potential within the device. For a better view, plot 5 slices in $x y$ planes.

## Electric Potential (es)

I In the Model Builder window, under Results click Electric Potential (es).
2 In the Settings window for 3D Plot Group, locate the Data section.
3 From the Parameter value (freq (Hz)) list, choose 5.II2E6.

## Multislice I

I In the Model Builder window, expand the Electric Potential (es) node, then click Multislice I .

2 In the Settings window for Multislice, locate the Multiplane Data section.
3 Find the $\mathbf{x}$-planes subsection. In the Planes text field, type 5.
4 Find the $\boldsymbol{y}$-planes subsection. In the Planes text field, type 0 .
5 Find the $\mathbf{z}$-planes subsection. In the Planes text field, type 0.
6 On the Electric Potential (es) toolbar, click Plot.
Add a plot to show the mechanical response of the device.

## ID Plot Group 3

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, type Mechanical Response in the Label text field.

## Point Graph I

I Right-click Mechanical Response and choose Point Graph.
2 Select Point 8 only.
3 In the Settings window for Point Graph, click Replace Expression in the upper-right corner of the $\mathbf{y}$-axis data section. From the menu, choose Component I>Solid Mechanics> Displacement>Displacement field (material and geometry frames)>u - Displacement field, X component.

4 Locate the $\boldsymbol{y}$-Axis Data section. From the Unit list, choose $\mathbf{n m}$.
5 Locate the $\mathbf{x}$-Axis Data section. From the Unit list, choose MHz.
6 On the Mechanical Response toolbar, click Plot.
Now set up a study to compute the frequency response of the device with different capacitors added in series.

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Frequency Domain.

4 Click Add Study in the window toolbar.
5 On the Home toolbar, click Add Study to close the Add Study window.

## STUDY 2

## Step I: Frequency Domain

I In the Model Builder window, under Study 2 click Step I: Frequency Domain.
2 In the Settings window for Frequency Domain, locate the Study Settings section.
3 Click Range.
4 In the Range dialog box, type $5.095[\mathrm{MHz}]$ in the Start text field.
5 In the Step text field, type $1[\mathrm{kHz}]$.
6 In the Stop text field, type $5.13[\mathrm{MHz}]$.
7 Click Replace.
8 In the Settings window for Frequency Domain, locate the Physics and Variables Selection section.

9 Select the Modify physics tree and variables for study step check box.
10 In the Physics and variables selection tree, select Component I (compl)>
Electrostatics (es)>Terminal 2.
II Click Disable.

## Parametric Sweep

I On the Study toolbar, click Parametric Sweep.
2 In the Settings window for Parametric Sweep, locate the Study Settings section.

## 3 Click Add.

4 In the table, enter the following settings:

| Parameter name | Parameter value list | Parameter unit |
| :--- | :--- | :--- |
| Cs | 0.10 .41 | pF |

5 In the Model Builder window, click Study 2.
6 In the Settings window for Study, locate the Study Settings section.
7 Clear the Generate default plots check box.
8 On the Study toolbar, click Compute.

## RESULTS

Re-plot the mechanical response with the additional series capacitance.

## Mechanical Response I

I In the Model Builder window, under Results right-click Mechanical Response and choose Duplicate.

2 In the Settings window for ID Plot Group, type Mechanical response, Parametric in the Label text field.

3 Locate the Data section. From the Data set list, choose Study 2/ Parametric Solutions I (sol3).
4 Click to expand the Legend section. From the Position list, choose Upper left.

## Point Graph I

I In the Model Builder window, expand the Results>Mechanical response, Parametric node, then click Point Graph I.
2 In the Settings window for Point Graph, click to expand the Legends section.
3 Select the Show legends check box.
4 On the Mechanical response, Parametric toolbar, click Plot.
Note how the mechanical resonant frequency is 'pulled' by the series capacitance.

## Thin-Film BAW Composite Resonator

## Introduction

Bulk acoustic wave (BAW) resonators can be used as narrow band filters in radio-frequency applications. Their chief advantage compared with traditional ceramic electromagnetic resonators is that they can be made smaller in size because they can be designed to have an acoustic wavelength smaller than the electromagnetic wavelength.

In addition to the desired bulk acoustic mode, the resonator structure may have many spurious modes with very narrow spacing. The design goal is usually to maximize the quality of the main component and to reduce the effect of spurious modes.

This tutorial shows how you can model thin-film BAW resonators in 2D using eigenfrequency and frequency-response analyses. The geometry used here is the same as that in Ref. 1 and Ref. 2.


Figure 1: Arbitrarily scaled geometry of a thin film BAW resonator.

## Model Definition

Figure 1 shows the geometry of the resonator from Ref. 1. The lowest layer of the resonator is silicon. On top of that, there is an aluminum layer that operates as the ground electrode. Above the aluminum layer is the active piezoelectric layer made of zinc oxide
$(\mathrm{ZnO})$. The topmost layer of the resonator is an aluminum electrode. The material properties used in this model are obtained from the MEMS Module material library.

A large part of the silicon layer is etched away from the lower end of the central region of the resonator structure. This effectively reduces the thickness of the active central region thereby making the device a thin-film composite BAW resonator.

The thickness of the silicon layer at the central region is $7 \mu \mathrm{~m}$. Both aluminum layers are $0.2 \mu \mathrm{~m}$ thick, and the piezoelectric layer is $9.5 \mu \mathrm{~m}$ thick. The width of the rectangular top electrode is $500 \mu \mathrm{~m}$. The thin silicon area is roughly 1.7 mm wide.


Figure 2: The 2D geometry (not drawn to scale) used in the tutorial.
This example is modeled in 2 D , using the plane strain assumption where the out-of-plane thickness is specified to be 1.7 mm . The modeled geometry (Figure 2) is a symmetric 1 mm section in the center of the resonator. The Perfectly Matched Layer (PML) domains used on the two sides effectively increase the length of the resonator and simulates the effect of propagation and absorption of elastic waves in the adjoining regions which are not resolved in the true geometric scale.

The absorption of elastic waves in the PML domains contribute to the damping of the structure. This is also known as anchor loss. Additionally, the model also incorporates mechanical and electrical losses in the piezoelectric zinc oxide layer by means of loss factors. A structural loss factor represents the hysteresis in a stress-strain curve and a dielectric loss factor represents the polarization loss, which manifests itself as the hysteresis
in the polarization versus electric field curve of the material. The structural and dielectric loss factors appear as the imaginary components of the mechanical stiffness and relative permittivity, respectively.

Ref. 3 gives the material quality $Q_{\mathrm{m}}$ and the dielectric loss tangent tan $\delta$ for many materials. The magnitude of $Q_{\mathrm{m}}$ is roughly $100-1000$, and the magnitude of $\tan \delta$ is roughly $0.001-0.01$. Based on that data, the following values are used:

- Structural loss factor: $\eta_{\mathrm{cE}}=0.001$.
- Dielectric loss factor: $\eta_{\varepsilon S}=0.01$.

In this model, COMSOL Multiphysics solves for both structural and electrical equations in the piezoelectric layer but only solves for the structural equation in the other layers. The electrical equations are not solved in the metallic aluminum layers because the electrical conductivity of aluminum is several orders of magnitude higher than that of zinc oxide and hence the aluminum layers almost act as equipotential regions allowing extremely small conduction current through them. Therefore the electrical characteristics of aluminum do not have any significant effect on the response of the resonator. The dominant electromechanical coupling is exhibited by the piezoelectric layer only.

This tutorial shows two different analyses. In the first step, you compute and investigate the eigenmodes of the structure, with its lateral ends fixed. In the second step, you analyze the frequency response of the resonator within the desired bandwidth of 215 MHz to 235 MHz .

## Results and Discussion

Figure 3 shows the lowest BAW mode of the structure which occurs at 221.4 MHz . This plot was generated from the results of the eigenfrequency analysis. This is the fundamental longitudinal thickness mode. The plot shows scaled deformation only to be used for visualization of the mode shape. Note that COMSOL Multiphysics computes complexvalued eigenfrequencies where the imaginary part gives a measure of the damping due to structural loss, polarization loss and anchor loss.

Eigenfrequency=2.214E8+8.361E4i Hz Surface: Total displacement ( $\mu \mathrm{m}$ )


Figure 3: The lowest bulk acoustic mode of the resonator identified from the solutions of the eigenfrequency analysis.


Figure 4: The lowest bulk acoustic mode of the resonator identified from the solutions of the frequency domain analysis.

Figure 4 shows the deformation of the resonator obtained from the frequency response analysis when the zinc oxide layer is excited with 1 volt (zero-to-peak voltage) at 221.5 MHz . The maximum deflection is about 3 nm .


Figure 5: Electric potential distribution in the zinc oxide layer at 235 MHz excitation.
Figure 5 shows the voltage distribution in the piezoelectric layer when excited at 235 MHz .

COMSOL Multiphysics' Terminal boundary condition which is used to specify the voltage on the piezoelectric material also automatically computes the admittance. The admittance is the ratio of the total current flowing through the piezoelectric material to the voltage across it. It is a complex-valued quantity for a lossy material. Typically the imaginary part reflects the displacement current and the real part reflects the conduction current as well as other losses in the structure. Figure 6 shows the absolute value of admittance as a function of frequency. Within the investigated range of 215 MHz to 235 MHz , the admittance is very similar to that shown in Ref. 2. Note that the highest peak in admittance occurs at the lowest BAW mode of 221 MHz .


Figure 6: Absolute value of the admittance vs. frequency.


Figure 7: Quality factor vs. frequency.

Figure 7 shows the quality factor of the device as a function of frequency. The quality factor or Q -factor indicates the number of cycles (at the given frequency) in which the total energy of the system decreases by a factor of $e^{2 \pi}$. This is also automatically computed by COMSOL Multiphysics. Figure 7 shows that the maximum value of $Q \sim 1300$ is obtained at around 221 MHz . This value obtained from the frequency-response analysis agrees well with the Q -factor computed by the eigenfrequency analysis. The results from the eigenfrequency analysis shows the Q -factor at 221.4 MHz to be 1326 .

The eigenfrequency analysis also automatically computes the decay factor for each eigenfrequency. The inverse of the decay factor is the time required for the amplitude of a damped signal to reduce to $e^{-1}$ of its initial amplitude. The decay factor at 221.4 MHz was computed to be $5.25 \cdot 10^{5} \mathrm{~s}^{-1}$.

## References

1. R.F. Milsom, J.E., Curran, S.L. Murray, S. Terry-Wood, and M. Redwood, "Effect of Mesa-Shaping on Spurious Modes in $\mathrm{ZnO} /$ Si Bulk-Wave Composite Resonators," Proc. IEEE Ultrason. Symp., pp. 498-503, 1983.
2. T. Makkonen, A. Holappa, J. Ellä, and M.M. Salomaa, "Finite element simulations of thin-film composite BAW resonators," IEEE Transactions on Ultrasonics, Ferroelectrics, and Frequency Control, vol. 48, no. 5, 2001.
3. Morgan Advanced Materials, http://www.morganelectroceramics.com

Application Library path: MEMS_Module/Piezoelectric_Devices/ thin_film_baw_resonator

## Modeling Instructions

From the File menu, choose New.

## NEW

In the New window, click Model Wizard.

## MODEL WIZARD

I In the Model Wizard window, click 2D.
2 In the Select Physics tree, select Structural Mechanics>Piezoelectric Devices.

3 Click Add.
4 Click Study.
5 In the Select Study tree, select Preset Studies for Selected Physics Interfaces> Eigenfrequency.

6 Click Done.

GEOMETRY I
I In the Model Builder window, under Component I (compl) click Geometry I.
2 In the Settings window for Geometry, locate the Units section.
3 From the Length unit list, choose $\boldsymbol{\mu m}$.
Rectangle I (rl)
I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 1000.
4 In the Height text field, type 16.7.
5 Locate the Position section. From the Base list, choose Center.
6 Click to expand the Layers section. In the table, enter the following settings:

| Layer name | Thickness $(\boldsymbol{\mu m})$ |
| :--- | :--- |
| Layer 1 | 50 |

7 Select the Layers to the left check box.
8 Select the Layers to the right check box.
9 Clear the Layers on bottom check box.
IO Right-click Rectangle I (rI) and choose Build Selected.
Rectangle 2 (r2)
I Right-click Rectangle I (rI) and choose Duplicate.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Height text field, type 0.2.
4 Locate the Position section. In the $y$ text field, type -1.25.
5 Right-click Component I (compl)>Geometry I>Rectangle 2 ( $\mathbf{r} \mathbf{2}$ ) and choose Build Selected.

## Rectangle 3 (r3)

I On the Geometry toolbar, click Primitives and choose Rectangle.
2 In the Settings window for Rectangle, locate the Size and Shape section.
3 In the Width text field, type 500.
4 In the Height text field, type 0.2.
5 Locate the Position section. From the Base list, choose Center.
6 In the $y$ text field, type 8.45.
7 Click Build All Objects.

## DEFINITIONS

In the Model Builder window, expand the Component I (compl)>Definitions node.
Axis
Change the aspect ratio to have a better view of the model, and make the domain selections easier.

I In the Model Builder window, expand the Component I (compl)>Definitions>View I node, then click Axis.
2 In the Settings window for Axis, locate the Axis section.
3 From the View scale list, choose Automatic.
4 Click Update.

5 Click the Zoom Extents button on the Graphics toolbar.


## Perfectly Matched Layer I (pmll)

I On the Definitions toolbar, click Perfectly Matched Layer.
2 In the Settings window for Perfectly Matched Layer, locate the Domain Selection section.

## 3 Click Paste Selection.

4 In the Paste Selection dialog box, type 1-3,8-10 in the Selection text field.

## 5 Click OK.

In this way you specify that the layers on the two sides of the geometry form a perfectly matched layer.

## ADD MATERIAL

I On the Home toolbar, click Add Material to open the Add Material window.
2 Go to the Add Material window.
3 In the tree, select MEMS>Semiconductors>Si - Silicon (single-crystal, anisotropic).
4 Click Add to Component in the window toolbar.

## ADD MATERIAL

I Go to the Add Material window.

2 In the tree, select MEMS $>$ Metals $>$ AI - Aluminum / Aluminium.
3 Click Add to Component in the window toolbar.

## MATERIALS

AI-Aluminum / Aluminium (mat2)
I In the Model Builder window, under Component I (compI)>Materials click AI Aluminum / Aluminium (mat2).

2 In the Settings window for Material, locate the Geometric Entity Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 2579 in the Selection text field.
5 Click OK.

## ADD MATERIAL

I Go to the Add Material window.
2 In the tree, select Piezoelectric>Zinc Oxide.
3 Click Add to Component in the window toolbar.

## MATERIALS

## Zinc Oxide (mat3)

I On the Home toolbar, click Add Material to close the Add Material window.
2 In the Model Builder window, under Component I (compl)>Materials click Zinc Oxide (mat3).

3 In the Settings window for Material, locate the Geometric Entity Selection section.
4 Click Paste Selection.
5 In the Paste Selection dialog box, type 3610 in the Selection text field.
6 Click OK.

SOLID MECHANICS (SOLID)
I In the Model Builder window, under Component I (compl) click Solid Mechanics (solid).
2 In the Settings window for Solid Mechanics, locate the Thickness section.
3 In the $d$ text field, type $1.7[\mathrm{~mm}]$.
Piezoelectric Material I
I In the Model Builder window, under Component I (compl)>Solid Mechanics (solid) click Piezoelectric Material I.

2 In the Settings window for Piezoelectric Material, locate the Domain Selection section.
3 Click Clear Selection.

## 4 Click Paste Selection.

5 In the Paste Selection dialog box, type 3610 in the Selection text field.
6 Click OK.
These are piezoelectric domains.

## Mechanical Damping I

I In the Model Builder window, right-click Piezoelectric Material I and choose Mechanical Damping.
2 In the Settings window for Mechanical Damping, locate the Damping Settings section.
3 From the Damping type list, choose Isotropic loss factor.
4 From the $\eta_{\mathrm{S}}$ list, choose User defined. In the associated text field, type 0.001.

## Dielectric Loss I

I In the Model Builder window, under Component I (compl)>Solid Mechanics (solid) rightclick Piezoelectric Material I and choose Dielectric Loss.

2 In the Settings window for Dielectric Loss, locate the Dielectric Loss Settings section.
3 From the $\eta_{\varepsilon S}$ list, choose User defined. In the associated text field, type 0.01.

## Linear Elastic Material 2

I In the Model Builder window, right-click Solid Mechanics (solid) and choose Material Models>Linear Elastic Material.

2 In the Settings window for Linear Elastic Material, locate the Domain Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 148 in the Selection text field.
5 Click OK.
6 In the Settings window for Linear Elastic Material, locate the Linear Elastic Material section.

7 From the Solid model list, choose Anisotropic.
These are the silicon domains that are modeled as an anisotropic linear elastic material.
The remaining domains are the aluminum domains that are modeled as an isotropic linear elastic material.

## Fixed Constraint I

I Right-click Solid Mechanics (solid) and choose Fixed Constraint.

2 In the Settings window for Fixed Constraint, locate the Boundary Selection section.

## 3 Click Paste Selection.

4 In the Paste Selection dialog box, type $13527-29$ in the Selection text field.
5 Click OK.
These are the boundaries of the perfectly matched layers. In this way you indicate that the device is fixed on its sides that are far away from the region that you are modeling.

## ELECTROSTATICS (ES)

On the Physics toolbar, click Solid Mechanics (solid) and choose Electrostatics (es).
I In the Model Builder window, under Component I (compl) click Electrostatics (es).
2 In the Settings window for Electrostatics, locate the Domain Selection section.
3 Click Clear Selection.
4 Click Paste Selection.
5 In the Paste Selection dialog box, type 3610 in the Selection text field.
6 Click OK.
7 In the Settings window for Electrostatics, locate the Thickness section.
8 In the $d$ text field, type $1.7[\mathrm{~mm}]$.

## Ground I

I Right-click Component I (comp I)>Electrostatics (es) and choose Ground.
2 In the Settings window for Ground, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 61325 in the Selection text field.
5 Click OK.

## Terminal I

I In the Model Builder window, right-click Electrostatics (es) and choose the boundary condition Terminal.

2 In the Settings window for Terminal, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 16 in the Selection text field.
5 Click OK.
6 In the Settings window for Terminal, locate the Terminal section.
7 From the Terminal type list, choose Voltage.

## MESH I

Distribution I
I In the Model Builder window, under Component I (compl) right-click Mesh I and choose Mapped.

2 Right-click Mapped I and choose Distribution.
3 In the Settings window for Distribution, locate the Boundary Selection section.
4 Click Paste Selection.
5 In the Paste Selection dialog box, type 221 in the Selection text field.
6 Click OK.

## Distribution 2

I Right-click Mapped I and choose Distribution.
2 In the Settings window for Distribution, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 9 in the Selection text field.
5 Click OK.
6 In the Settings window for Distribution, locate the Distribution section.
7 In the Number of elements text field, type 100.

## Distribution 3

I Right-click Mapped I and choose Distribution.
2 In the Settings window for Distribution, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 8 in the Selection text field.
5 Click OK.
6 In the Settings window for Distribution, locate the Distribution section.
7 In the Number of elements text field, type 2.

## Distribution 4

I Right-click Mapped I and choose Distribution.
2 In the Settings window for Distribution, locate the Boundary Selection section.
3 Click Paste Selection.
4 In the Paste Selection dialog box, type 12 in the Selection text field.
5 Click OK.

6 In the Settings window for Distribution, locate the Distribution section.
7 In the Number of elements text field, type 3.

## 8 Click Build AII.

The mesh should look as shown in this figure.


## STUDY I

Step I: Eigenfrequency
I In the Model Builder window, under Study I click Step I: Eigenfrequency.
2 In the Settings window for Eigenfrequency, locate the Study Settings section.
3 Select the Search for eigenfrequencies around check box.
4 In the associated text field, type $220[\mathrm{MHz}]+i * 150[\mathrm{kHz}]$.
5 From the Eigenfrequency search method around shift list, choose Smaller imaginary part.
6 Right-click Study I>Step I: Eigenfrequency and choose Get Initial Value for Step.
7 In the Model Builder window, expand the Study I>Solver Configurations node.

## Solution I (soll)

I In the Model Builder window, expand the Study I>Solver Configurations>Solution I (solI) node, then click Eigenvalue Solver I.

2 In the Settings window for Eigenvalue Solver, locate the Values of Linearization Point section.

3 Find the Value of eigenvalue linearization point subsection. In the Point text field, type $2 e 8$.

4 Click Compute.

## DEFINITIONS

## Axis

Set the view to the default scale type for the result plots.
I In the Model Builder window, under Component I (compl)>Definitions>View I click Axis.
2 In the Settings window for Axis, locate the Axis section.
3 From the View scale list, choose None.
4 Click Update.
5 Click the Zoom Extents button on the Graphics toolbar.

## RESULTS

## Mode Shape (solid)

I In the Model Builder window, under Results click Mode Shape (solid).
2 In the Settings window for 2D Plot Group, locate the Data section.
3 From the Eigenfrequency $(\mathbf{H z})$ list, choose $2.214 E 8+8.361 E 4 i$.
4 On the Mode Shape (solid) toolbar, click Plot.
Compare this plot with .

## ADD STUDY

I On the Home toolbar, click Add Study to open the Add Study window.
2 Go to the Add Study window.
3 Find the Studies subsection. In the Select Study tree, select Preset Studies> Frequency Domain.
4 Click Add Study in the window toolbar.

STUDY 2
Step I: Frequency Domain
I On the Home toolbar, click Add Study to close the Add Study window.

2 In the Model Builder window, click Step I: Frequency Domain.
3 In the Settings window for Frequency Domain, locate the Study Settings section.
4 In the Frequencies text field, type range $(215,0.1,235)[\mathrm{MHz}]$.
5 On the Home toolbar, click Compute.

## RESULTS

Stress (solid)
I In the Model Builder window, click Stress (solid).
2 In the Settings window for 2D Plot Group, type Displacement (solid) in the Label text field.

3 Locate the Data section. From the Parameter value (freq (Hz)) list, choose 2.2I5E8.

## Surface I

I In the Model Builder window, expand the Results>Displacement (solid) node, then click Surface I.

2 In the Settings window for Surface, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I>Solid Mechanics> Displacement>solid.disp - Total displacement.

3 On the Displacement (solid) toolbar, click Plot.
4 Click the Zoom Extents button on the Graphics toolbar.
Compare this plot with .
Electric Potential (es) I
I In the Model Builder window, under Results click Electric Potential (es) I.
2 On the Electric Potential (es) I toolbar, click Plot.
Compare this plot with .

## ID Plot Group 5

I On the Home toolbar, click Add Plot Group and choose ID Plot Group.
2 In the Settings window for ID Plot Group, type Admittance in the Label text field.
3 Locate the Data section. From the Data set list, choose Study 2/Solution 2 (sol2).

## Global I

I Right-click Admittance and choose Global.
2 In the Settings window for Global, locate the y-Axis Data section.

3 In the table, enter the following settings:

| Expression | Unit | Description |
| :--- | :--- | :--- |
| abs(es.Y11) | S | Absolute value of admittance |

4 Locate the x-Axis Data section. From the Unit list, choose MHz.
5 On the Admittance toolbar, click Plot.
6 Click the $\mathbf{y}$-Axis Log Scale button on the Graphics toolbar.
Compare this plot with .

## Admittance I

I In the Model Builder window, under Results right-click Admittance and choose Duplicate.
2 In the Settings window for ID Plot Group, type Quality Factor in the Label text field.

## Global I

I In the Model Builder window, expand the Results>Quality Factor node, then click Global I.

2 In the Settings window for Global, click Replace Expression in the upper-right corner of the $\boldsymbol{y}$-axis data section. From the menu, choose Component I>Solid Mechanics>Global> solid.Q_freq - Quality factor for frequency.
3 Click the $\mathbf{y}$-Axis Log Scale button on the Graphics toolbar.
4 On the Quality Factor toolbar, click Plot.
Compare this plot with .
The following steps show how to compute the quality factor and the decay factor for the resonance at 221.4 MHz from the eigenfrequency study. You will see that the value for the quality factor agrees well with that obtained from the frequency domain study at the same frequency.

## Global Evaluation I

I On the Results toolbar, click Global Evaluation.
2 In the Settings window for Global Evaluation, type Q-Factor in the Label text field.
3 Locate the Data section. From the Eigenfrequency selection list, choose From list.
4 In the Eigenfrequency $(\mathrm{Hz})$ list, select 2.214E8+8.36IE4i.
5 Click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Component I>Solid Mechanics>Global>solid.Q_eig Quality factor for eigenvalue.

6 Click Evaluate.

## Q-Factor I

I Right-click Q-Factor and choose Duplicate.
2 In the Settings window for Global Evaluation, click Replace Expression in the upper-right corner of the Expressions section. From the menu, choose Component I> Solid Mechanics>Global>solid.decay - Exponential decay factor.
3 In the Label text field, type Decay Factor.
4 Click Evaluate.


[^0]:    1. Xducer ${ }^{\text {TM }}$ is believed to be a trademark of Freescale Semiconductor, Inc. f/k/a Motorola, Inc. Neither Freescale Semiconductor Inc. nor Motorola, Inc. has in any way provided any sponsorship or endorsement of, nor do they have any connection or involvement with, COMSOL Multiphysics ${ }^{\circledR}$ software or this model.
[^1]:    1. Xducer ${ }^{\text {TM }}$ is believed to be a trademark of Freescale Semiconductor, Inc. f/k/a Motorola, Inc. Neither Freescale Semiconductor, Inc. nor Motorola, Inc. has in any way provided any sponsorship or endorsement of, nor do they have any connection or involvement with, COMSOL Multiphysics software or this model.
